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e-mail: sales@gelest.com
Correspondence: 11 East Steel Rd.

Morrisville, PA 19067

#### For further information consult our web site at: www.gelest.com

In Europe:

Gelest Inc.

Stroofstrasse 27 Geb.2901 65933 Frankfurt am Main,

Germany

Tel: +49-(0)-69-3800-2150 Fax: +49-(0)-69-3800-2300 e-mail: info@gelestde.com Internet: www.gelestde.com

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AZmax Co. Ltd. Tokyo Office

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**Front Cover Photos:** Water rolls off a duck's back. Lotus leaves exhibit superhydrophobicity. Biological systems are dependent on water, but at the same time must control the interaction. In a sense, all living organisms exhibit behaviors that can be described as both hydrophobic and hydrophilic.

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# Gelest Hydrophobicity, Hydrophilicity

# and Silane Surface Modification

by Barry Arkles

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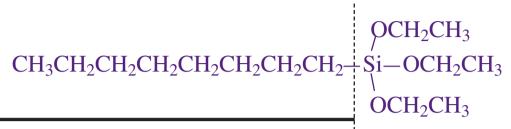
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Hydrophobicity, Hydrophilicity and Silane Surface Modification Barry Arkles ©2011 Gelest, Inc.



#### **Silanes and Surface Modification**

Silanes are silicon chemicals that possess a hydrolytically sensitive center that can react with inorganic substrates such as glass to form stable covalent bonds and possess an organic substitution that alters the physical interactions of treated substrates.



organic substitution allows permanent property modification

hydrolyzable alkoxy (alcohol) groups

#### **Property modifications include:**

Hydrophobicity
Adhesion
Release
Dielectric
Absorption
Orientation
Hydrophilicity
Charge Conduction

#### **Applications include:**

Architectural Coatings
Water-Repellents
Anti-stiction Coatings for MEMs
Mineral Surface Treatments
Fillers for Composites
Pigment Dispersants
Dielectric Coatings
Anti-fog Coatings
Release Coatings
Optical (LCD) Coatings

**Bonded Phases** 

Self-Assembled Monolayers (SAMs)

Crosslinkers for Silicones Nanoparticle Synthesis Anti-Corrosion Coatings

In contrast with silanes utilized as coupling agents in adhesive applications, silanes used to modify the surface energy or wettability of substrates under normal conditions do not impart chemical reactivity to the substrate. They are often referred to as non-functional silanes. The main classes of silanes utilized to effect surface energy modification without imparting reactivity are:

#### **Hydrophobic Silanes**

Methyl Linear Alkyl Branched Alkyl Fluorinated Alkyl Aryl Dipodal

#### **Hydrophilic Silanes**

Masked

Polar Hydroxylic Ionic Charge inducible / charge switchable Embedded Hydrophilicity

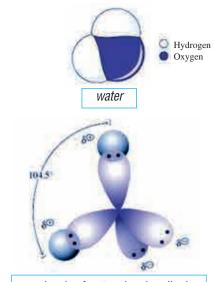
## Water, Hydrophobicity and Hydrophilicity

**Hydrophobic** and **Hydrophilic** are frequently used descriptors of surfaces. A surface is hydrophobic if it tends *not to* adsorb water or be wetted by water. A surface is hydrophilic if it tends *to* adsorb water or be wetted by water. More particularly, the terms describe the interaction of the boundary layer of a solid phase with liquid or vapor water. Silanes can be used to modify the interaction of boundary layers of solids with water with a high degree of control, effecting variable degrees of hydrophobicity or hydrophilicity.

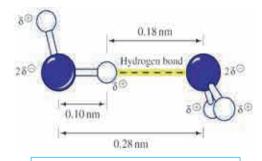
Since the interaction of water with surfaces is frequently used to define surface properties, a brief review of its structure and properties can be helpful. Although the structure of water is a subject of early discussion in the study of physical sciences, it is interesting to note that the structure of liquid water is still not solved and, even so, most technologists lose appreciation of what is known about its structure and properties.

The quantum calculation of the structure of an isolated H<sub>2</sub>O molecule has evolved to the currently accepted model which demonstrates a strong dipole, but no lone electron pairs associated with sp<sup>3</sup> hybridized orbitals of oxygen. This model of isolated H<sub>2</sub>O conforms most closely to the vapor state and extrapolation often leads to the conclusion that water is a collection of individual molecules which associate with each other primarily through dipole interactions. The polar nature of water, with its partial positive and partial negative dipole, explains why bulk water readily dissolves many ionic species and interacts with ionic surfaces. The difference between isolated vapor phase water and bulk liquid water is much more extreme than can be accounted for by a model relying only on dipole interactions. The properties of bulk liquid water are strongly influenced by hydrogen bond interactions. In the liquid state, despite 80% of the electrons being concerned with bonding, the three atoms of a water molecule do not stay together as discrete molecules. The hydrogen atoms are constantly exchanging between water molecules in a protonation-deprotonation process. Both acids and bases catalyze hydrogen exchange and, even when at its slowest rate of exchange (at pH 7), the average residence time of a hydrogen atom is only about a millisecond. In the liquid state, water molecules are bound to each other by an average of three hydrogen bonds. Hydrogen bonds arise when a hydrogen that is covalently bound to an oxygen in one molecule of water nears another oxygen from another water molecule. The electrophilic oxygen atom "pulls" the hydrogen closer to itself. The end result is that the hydrogen is now shared (unequally) between the oxygen to which it is covalently bound and the electrophilic oxygen to which it is attracted (O-H···O). Each hydrogen bond has an average energy of 20 kJ/mol. This is much less than an O-H covalent bond, which is 460 kJ/ mol. Even though an individual hydrogen bond is relatively weak, the large number of hydrogen bonds that exist in water which pull the molecules together have a significant role in giving water its special bulk properties. In ice, water molecules are highly organized with four hydrogen bonds. Liquid water is thought to be a combination of domains of molecules with 3-4 hydrogen bonds separated by domains with 2-3 hydrogen bonds, subject to constant turnover - the *flickering cluster model*.

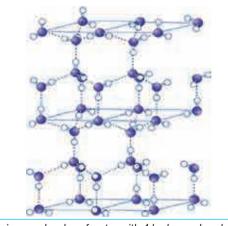
This brief description of water is provided in order to give the insight that whenever a solid surface interacts with bulk water it is interacting with a soft matter structure, not simply a collection of individual molecules. Surface interactions with water must compete with a variety of internal interactions of liquid phase water: van der Waals forces, dipole interactions, hydrogen bonding and proton exchange.



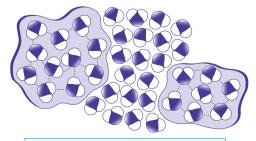
molecule of water showing dipole



2 molecules showing hydrogen bond



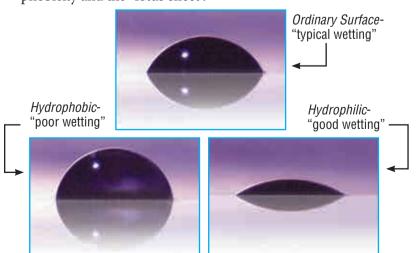
ice - molecules of water with 4 hydrogen bonds

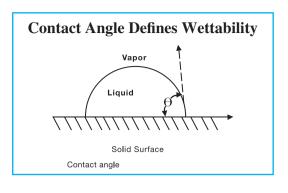


liquid water - flickering cluster model regions of molecules with 3-4 hydrogen bonds separated by regions with 2-3 hydrogen bonds (not shown: out of plane hydrogen bonds)

## Wettability and Contact Angle

A surface is said to be wetted if a liquid spreads over the surface evenly without the formation of droplets. When the liquid is water and it spreads over the surface without the formation of droplets, the surface is said to be hydrophilic. In terms of energetics, this implies that the forces associated with the interaction of water with the surface are greater than the cohesive forces associated with bulk liquid water. Water droplets form on hydrophobic surfaces, implying that the cohesive forces associated with bulk water are greater than the forces associated with the interaction of water with the surface. Practically, hydrophobicity and hydrophilicity are relative terms. A simple quantitative method for defining the relative degree of interaction of a liquid with a solid surface is the contact angle of a liquid droplet on a solid substrate. If the contact angle of water is less than 30°, the surface is designated hydrophilic since the forces of interaction between water and the surface nearly equal the cohesive forces of bulk water and water does not cleanly drain from the surface. If water spreads over a surface and the contact angle at the spreading front edge of the water is less than 10°, the surface is often designated as superhydrophilic (provided that the surface is not absorbing the water, dissolving in the water or reacting with the water). On a hydrophobic surface, water forms distinct droplets. As the hydrophobicity increases, the contact angle of the droplets with the surface increases. Surfaces with contact angles greater than 90° are designated as hydrophobic. The theoretical maximum contact angle for water on a smooth surface is 120°. Micro-textured or micro-patterned surfaces with hydrophobic asperities can exhibit apparent contact angles exceeding 150° and are associated with superhydrophobicity and the "lotus effect".





Contact Angle of Wate Smooth Surfaces	r on
	θ
heptadecafluorodecyltrimethoxysilane*	115°
(heptafluoroisopropoxy)propyl-	
trichlorosilane*	109-111°
poly(tetrafluoroethylene)	108-112°
poly(propylene)	108°
octadecyldimethylchlorosilane*	110°
octadecyltrichlorosilane*	102-109°
tris(trimethylsiloxy)- silylethyldimethylchlorosilane	104°
octyldimethylchlorosilane*	104°
dimethyldichlorosilane*	95-105°
butyldimethylchlorosilane*	100°
trimethylchlorosilane*	90-100°
poly(ethylene)	88-103°
poly(styrene)	94°
poly(chlorotrifluoroethylene)	90°
human skin	75-90°
diamond	87°
graphite	86°
silicon (etched)	86-88°
talc	50-55°
chitosan	80-81°
steel	70-75°
methacryloxypropyltrimethoxysilane	70°
gold, typical (see gold, clean)	66°
triethoxysilylpropoxy(triethylenoxy)-	
dodecanoate*	61-2°
intestinal mucosa	50-60°
glycidoxypropyltrimethoxysilane*	49°
kaolin	42-46°
platinum	40°
silicon nitride	28-30°
silver iodide	17°
methoxy(polyethyleneoxy)propyl- trimethoxysilane*	15.5°
soda-lime glass	<15°

\*Note: Contact angles for silanes refer to smooth treated

<10°

gold, clean

#### **Critical Surface Tension and Adhesion**

While the contact angle of water on a substrate is a good indicator of the relative hydrophobicity or hydrophilicity of a substrate, it is not a good indicator for the wettability of the substrate by other liquids. The contact angle is given by Young's equation:

$$\gamma_{sv} - \gamma_{sl} = \gamma_{lv} \cdot cos\theta_{e}$$

where  $\gamma_{sl}$  = interfacial surface tension,  $\gamma_{lv}$  = surface tension of liquid.

Critical surface tension is associated with the wettability or release properties of a solid. It serves as a better predictor of the behavior of a solid with a range of liquids.

Liquids with a surface tension below the critical surface tension ( $\gamma_c$ ) of a substrate will wet the surface, i.e., show a contact angle of 0 ( $\cos\theta_e = 1$ ). The critical surface tension is unique for any solid and is determined by plotting the cosine of the contact angles of liquids of different surface tensions and extrapolating to 1.

Hydrophilic behavior is generally observed by surfaces with critical surface tensions greater than 45 dynes/cm. As the critical surface tension increases, the expected decrease in contact angle is accompanied with stronger adsorptive behavior and with increased exotherms.

Hydrophobic behavior is generally observed by surfaces with critical surface tensions less than 35 dynes/cm. At first, the decrease in critical surface tension is associated with oleophilic behavior, i.e. the wetting of the surfaces by hydrocarbon oils. As the critical surface tensions decrease below 20 dynes/cm, the surfaces resist wetting by hydrocarbon oils and are considered oleophobic as well as hydrophobic.

In the reinforcement of thermosets and thermoplastics with glass fibers, one approach for optimizing reinforcement is to match the critical surface tension of the silylated glass surface to the surface tension of the polymer in its melt or uncured condition. This has been most helpful in resins with no obvious functionality such as polyethylene and polystyrene. Silane treatment has allowed control of thixotropic activity of silica and clays in paint and coating applications. Immobilization of cellular organelles, including mitochondria, chloroplasts, and microsomes, has been effected by treating silica with alkylsilanes of  $C_8$  or greater substitution.

#### **Critical surface tensions**

	$\gamma_{c}$
	mN/m
heneicosafluorododecyltrichlorosilane	6-7
heptadecafluorodecyltrichlorosilane	12.0
poly(tetrafluoroethylene)	18.5
octadecyltrichlorosilane	20-24
methyltrimethoxysilane	22.5
nonafluorohexyltrimethoxysilane	23.0
vinyltriethoxysilane	25
paraffin wax	25.5
ethyltrimethoxysilane	27.0
propyltrimethoxysilane	28.5
glass, soda-lime (wet)	30.0
poly(chlorotrifluoroethylene)	31.0
poly(propylene)	31.0
poly(propylene oxide)	32
polyethylene	33.0
trifluoropropyltrimethoxysilane	33.5
3-(2-aminoethyl)-aminopropyltrimethoxysilane	33.5
poly(styrene)	34
p-tolyltrimethoxysilane	34
cyanoethyltrimethoxysilane	34
aminopropyltriethoxysilane	35
acetoxypropyltrimethoxylsilane	37.5
polymethylmethacrylate	39
polyvinylchloride	39
phenyltrimethoxysilane	40.0
chloropropyltrimethoxysilane	40.5
mercaptopropyltrimethoxysilane	41
glycidoxypropyltrimethoxysilane	42.5
poly(ethyleneterephthalate)	43
poly(ethylene oxide)	43-45
copper (dry)	44
aluminum (dry)	45
iron (dry)	46
nylon 6/6	45-6
glass, soda-lime (dry)	47
silica, fused	78
titanium dioxide (anatase)	91
ferric oxide	107
tin oxide	111
Note: Critical surface tensions for silanes refer to smooth to surfaces	eated

#### How does a Silane Modify a Surface?

Most of the widely used organosilanes have one organic substituent and three hydrolyzable substituents. In the vast majority of surface treatment applications, the alkoxy groups of the trialkoxysilanes are hydrolyzed to form silanol-containing species. Reaction of these silanes involves four steps. Initially, hydrolysis of the three labile groups occurs. Condensation to oligomers follows. The oligomers then hydrogen bond with OH groups of the substrate. Finally, during drying or curing, a covalent linkage is formed with the substrate with concomitant loss of water. Although described sequentially, these reactions can occur simultaneously after the initial hydrolysis step. At the interface, there is usually only one bond from each silicon of the organosilane to the substrate surface. The two remaining silanol groups are present either in condensed or free form. The R group remains available for covalent reaction or physical interaction with other phases.

Silanes can modify surfaces under anhydrous conditions consistent with monolayer and vapor phase deposition requirements. Extended reaction times (4-12 hours) at elevated temperatures (50°-120°C) are typical. Of the alkoxysilanes, only methoxysilanes are effective without catalysis. The most effective silanes for vapor phase deposition are cyclic azasilanes.

#### **Hydrolysis Considerations**

Water for hydrolysis may come from several sources. It may be added, it may be present on the substrate surface, or it may come from the atmosphere. The degree of polymerization of the silanes is determined by the amount of water available and the organic substituent. If the silane is added to water and has low solubility, a high degree of polymerization is favored. Multiple organic substitution, particularly if phenyl or tertiary butyl groups are involved, favors formation of stable monomeric silanols.

The thickness of a polysiloxane layer is also determined by the concentration of the siloxane solution. Although a monolayer is generally desired, multilayer adsorption results from solutions customarily used. It has been calculated that deposition from a 0.25% silane solution onto glass could result in three to eight molecular layers. These multilayers could be either interconnected through a loose network structure, or intermixed, or both, and are, in fact, formed by most deposition techniques. The orientation of functional groups is generally horizontal, but not necessarily planar, on the surface of the substrate.

The formation of covalent bonds to the surface proceeds with a certain amount of reversibility. As water is removed, generally by heating to 120°C for 30 to 90 minutes or evacuation for 2 to 6 hours, bonds may form, break, and reform to relieve internal stress.

#### **Hydrolytic Deposition of Silanes**

B. Arkles, CHEMTECH, 7, 766, 1977

#### **Anhydrous Deposition of Silanes**

$$H_{3}C-Si-CH_{3}$$
 $OCH_{3}$ 
 $+$ 
 $OH$ 
 $A$ 
 $CH_{3}OH$ 
 $R$ 
 $CH_{3}OH$ 
 $R$ 
 $CH_{3}C-Si-CH_{3}$ 
 $CH_{3}OH$ 



# Selecting A Silane for Surface Modification - Inorganic Substrate Perspective

Factors influencing silane surface modification selection include:

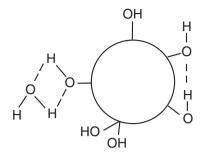
Concentration of surface hydroxyl groups
Type of surface hydroxyl groups
Hydrolytic Stability of the bond formed
Physical dimensions of the substrate or substrate features

Surface modification is maximized when silanes react with the substrate surface and present the maximum number of accessible sites with appropriate surface energies. An additional consideration is the physical and chemical properties of the interphase region. The interphase can promote or detract from total system properties depending on its physical properties such as modulus or chemical properties such as water/hydroxyl content.

Hydroxyl-containing substrates vary widely in concentration and type of hydroxyl groups present. Freshly fused substrates stored under neutral conditions have a minimum number of hydroxyls. Hydrolytically derived oxides aged in moist air have significant amounts of physically adsorbed water which can interfere with coupling. Hydrogen bonded vicinal silanols react more readily with silane coupling agents, while isolated or free hydroxyls react reluctantly.

Silanes with three alkoxy groups are the usual starting point for substrate modification. These materials tend to deposit as polymeric films, effecting total coverage and maximizing the introduction of organic functionality. They are the primary materials utilized in composites, adhesives, sealants, and coatings. Limitations intrinsic in the utilization of a polylayer deposition are significant for nano-particles or nano-composites where the interphase dimensions generated by polylayer deposition may approach those of the substrate. Residual (non-condensed) hydroxyl groups from alkoxysilanes can also interfere in activity. Monoalkoxy-silanes provide a frequently used alternative for nano-featured substrates since deposition is limited to a monolayer.

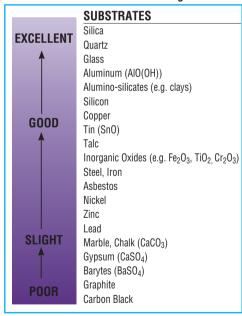
If the hydrolytic stability of the oxane bond between the silane and the substrate is poor or the application is in an aggressive aqueous environment, dipodal silanes often exhibit substantial performance improvements. These materials form tighter networks and may offer up to 10<sup>5</sup>x greater hydrolysis resistance making them particularly appropriate for primer applications.





Water droplets on a (heptadecafluoro-1,1,2,2-tetrahy-drodecyl)trimethoxysilane-treated silicon wafer exhibit high contact angles, indicative of the low surface energy. Surfaces are both hydrophobic and resist wetting by hydrocarbon oils. (water droplets contain dye for photographic purposes).

#### Silane Effectiveness on Inorganics



#### **Estimates for Silane Loading on Siliceous Fillers**

Average Particle Size	Amount of Silane (minimum of monolayer coverage)
<1 micron	1.5%
1-10 microns	1.0%
10-20 microns	0.75%
>100 microns	0.1% or less

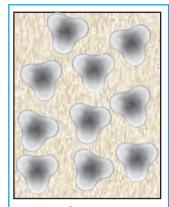
#### **Hydrophobic Silane Surface Treatments**

Factors which contribute to the ability of an organosilane to generate a hydrophobic surface are its organic substitution, the extent of surface coverage, residual unreacted groups (both from the silane and the surface) and the distribution of the silane on the surface.

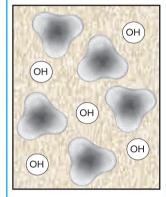
Aliphatic hydrocarbon substituents or fluorinated hydrocarbon substituents are the hydrophobic entities which enable silanes to induce surface hydrophobicity. Beyond the simple attribute that in order to generate a hydrophobic surface the organic substitution of the silane must be non-polar, more subtle distinctions can be made. The hydrophobic effect of the organic substitution can be related to the free energy of transfer of hydrocarbon molecules from an aqueous phase to a homogeneous hydrocarbon phase. For non-polar entities, van der Waals interactions are predominant factors in interactions with water and such interactions compete with hydrogen bonding in ordering of water molecules. Van der Waals interactions for solid surfaces are primarily related to the instantaneous polarizability of the solid which is proportional to the dielectric constant or permittivity at the primary UV absorption frequency and the refractive index of the solid. Entities which present sterically closed structures that minimize van der Waals contact are more hydrophobic than open structures that allow van der Waals contact. Thus, in comparison to polyethylene, both polypropylene and polytetrafluoroethylene are more hydrophobic. Similarly methyl-substituted alkylsilanes and fluorinated alkylsilanes provide better hydrophobic surface treatments than linear alkyl silanes.

Surfaces to be rendered hydrophobic usually are polar with a distribution of hydrogen bonding sites. A successful hydrophobic coating must eliminate or mitigate hydrogen bonding and shield polar surfaces from interaction with water by creating a non-polar interphase. Hydroxyl groups are the most common sites for hydrogen bonding. The hydrogens of hydroxyl groups can be eliminated by oxane bond formation with an organosilane. The effectiveness of a silane in reacting with hydroxyls impacts hydrophobic behavior not only by eliminating the hydroxyls as water adsorbing sites, but also by providing anchor points for the non-polar organic substitution of the silane which shields the polar substrates from further interaction with water.

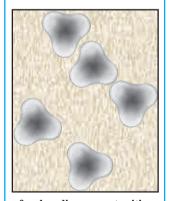
Strategies for silane surface treatment depend on the population of hydroxyl groups and their accessibility for bonding. A simple conceptual case is the reaction of organosilanes to form a monolayer. If all hydroxyl groups are capped by the silanes and the surface is effectively shielded, a hydrophobic surface is achieved. Practically, not all of the hydroxyl groups may react leaving residual sites for hydrogen bonding. Further, there may not be enough anchor points on the surface to allow the organic substituents to effectively shield the substrate. Thus the substrate reactive groups of the silane, the conditions of deposition, the ability of the silane to form monomeric or polymeric layers and the nature of the organic substitution all play a role in rendering a surface hydrophobic. The minimum requirements for hydrophobicity with the economic restrictions for various applications further complicate selection.



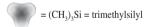
complete coverage



incomplete hydroxyl reaction



few bonding opportunities



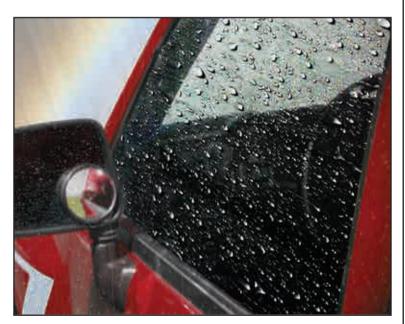
#### Hypothetical Trimethylsilylated Surfaces

Pyrogenic silica has 4.4-4.6 OH/nm<sup>2</sup>. Typically less than 50% are reacted. Other substrates have fewer opportunities for reaction.

#### Superhydrophobicity and Oleophobicity

Hydrophobicity is frequently associated with oleophilicity, the affinity of a substance for oils, since non-polar organic substitution is often hydrocarbon in nature and shares structural similarities with many oils. The hydrophobic and oleophilic effect can be differentiated and controlled. At critical surface tensions of 20-30 mN/m, surfaces are wetted by hydrocarbon oils and are water repellent. At critical surface tensions below 20, hydrocarbon oils no longer spread and the surfaces are both hydrophobic and oleophobic. The most oleophobic silane surface treatments have fluorinated long-chain alkyl silanes and methylated medium chain alkyl silanes.

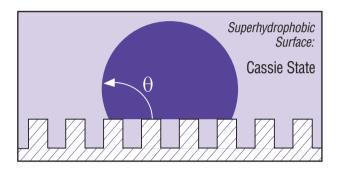
Superhydrophobic surfaces are those surfaces that present apparent contact angles that exceed the theoretical limit for smooth surfaces, i.e. >120°. The most common examples of superhydrophobicity are associated with surfaces that are rough on a sub-micron scale and contact angle measurements are composites of solid surface asperities and air; denoted as the *Cassie state*. Perfectly hydrophobic surfaces (contact angles of 180°) have been prepared by hydrolytic deposition of methylchlorosilanes as microfibrillar structures.

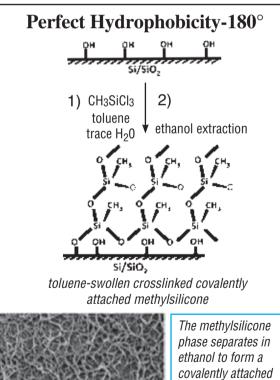


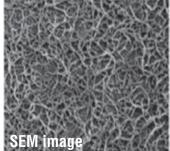
**Automotive side windows** are treated with fluoroalkylsilanes to provide self-cleaning properties. Water beads remove soil as they are blown over the glass substrate during acceleration.

#### **Hydrophobicity vs Water Permeability**

Although silane and silicone derived coatings are in general the most hydrophobic, they maintain a high degree of permeability to water vapor. This allows coatings to breathe and reduce deterioration at the coating interface associated with entrapped water. Since ions are not transported through non-polar silane and silicone coatings, they offer protection to composite structures ranging from pigmented coatings to rebar reinforced concrete.







The methylsilicone phase separates in ethanol to form a covalently attached fibrillar network. Fiber diameter is ~20 nm. Ellipsometry indicates a film thickness of ~20 nm.

T. McCarthy, J. Am. Chem. Soc., 2006, 128, 9052.

#### **Hydrophilic Silane Surface Treatments**

The vast majority of surfaces are hydrophilic. Water is omnipresent in the environment, yet the precise nature of interaction of water with specific surfaces is largely unknown. Water adsorption may be uniform or in isolated patches. It may be driven by a number of different physical and chemical processes. The adsorption of water by a surface may be assisted or retarded by other adsorbents present in the environment. The purpose of applying a hydrophilic surface treatment is to control both the nature and extent of interaction of water with a surface.

The controlled interaction of water with substrates can offer various degrees of hydrophilicity ranging from physi-sorption to chemi-sorption and centers for ion-interaction. The utility of hydrophilic surfaces varies widely. Anti-fog coatings exploit high surface energies to flatten water droplets rather than allowing them to form light-scattering droplets. In biological systems hydrophilic surfaces can reduce nonspecific bonding of proteins. Hydrophilic coatings with hydrogen bonding sites allow formation of tightly adherent layers of water with high lubricity in biological systems and the ability to resist oil adsorption in anti-graffiti coatings. They can also be used to disperse particles in aqueous coatings and oil-in-water emulsions. Hydrophilic coatings with ionic sites form antistatic coatings, dye receptive surfaces and can generate conductive or electrophoretic pathways. Thick films can behave as polymeric electrolytes in battery and ion conduction applications.

In general, surfaces become more hydrophilic in the series: non-polar < polar, no hydrogen-bonding < polar, hydrogen-bonding < hydroxylic < ionic. The number of sites and the structure and density of the interphase area also have significant influence on hydrophilicity.

Much of the discussion of hydrophobicity centers around high contact angles and their measurement. As a corollary, low or 0° contact angles of water are associated with hydrophilicity, but practically the collection of consistent data is more difficult. Discriminating between surfaces with a 0° contact angle is impossible. The use of heat of immersion is a method that generates more consistent data for solid surfaces, provided the surface does not react with, dissolve or absorb the tested liquid. Another important consideration is whether the water adsorbed is "free" or "bound." Free water is water that is readily desorbed under conditions of less than 100% relative humidity. If water remains bound to a substrate under conditions of less than 100%

Anti-fog coatings applied to one side of a visor can be prepared from combinations of polyalkylene oxide functional silanes and film-forming hydrophilic silanes.



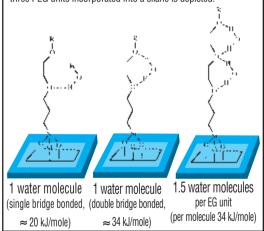
#### Heats of Immersion in Water, mJ/m

titanium dioxide	225-250
talc	220-260
aminopropyltriethoxysilane*	230-270
silicon dioxide	210-225
glass	200-205
vinyltris(methoxyethoxy)silane*	110-190
mercaptopropyltrimethoxysilane*	80-170
graphite	32-35
polytetrafluoroethylene	24-25
polytetranuoroethylene	24-20

\*Data for silane treated surfaces in this table is primarily from B. Marciniec et al, Colloid & Polymer Science, 261, 1435, 1983 recalculated for surface area.

#### Water Interaction with PEGylated Silanes

The most common strategy for non-hydroxylic polar modification of organic molecules is the incorporation of poleyethylene oxide units (PEG). The interaction of water with one, two and three PEG units incorporated into a silane is depicted.



relative humidity, the surface is considered hygroscopic. Another description of hygroscopic water is a boundary layer of water adsorbed on a surface less than 200nm thick that cannot be removed without heating. A measure of the relative hygroscopic nature of surfaces is given by the water activity, the ratio of the fugacity, or escaping tendency, of water from a surface compared to the fugacity of pure water.

The hydrophilicity of a surface as measured or determined by contact angle is subject to interference by loosely bound oils and other contaminants. Heats of immersion and water activity measurements are less subject to this interference. Measurements of silane-modified surfaces demonstrate true modification of the intrinsic surface properties of substrates. If the immobilized hydrophilic layer is in fact a thin hydrogel film, then swelling ratios at equilibrium water absorbtion can provide useful comparative data.



#### **Hydrophilic Silane Surface Treatments (continued)**

Controlling hydrophilic interaction with silane surface treatments is accomplished by the selection of a silane with the appropriate hydrophilic substitution. The classes of substitution are:

- Polar, Non-Hydrogen Bonding
- Polar, Hydrogen-Bonding
- Hydroxylic
- Ionic-Charged



Aortic stents are coated to promote hydrophilicity, coupling to polymers and drug delivery systems.

The selection of the class of hydrophilic subsitution is dependent on the application. If it is sufficient for water to spread evenly over a surface to form a thin film that washes away and dries off quickly without leaving 'drying spots', then a polar aprotic silane is preferred. If a coating is desired that reduces non-specific binding of proteins or other biofoulants, then a polar hydrogen-bonding material such as a polyether functional silane is preferred. A very different application for polar non-hydroxylic materials is thin film proton conduction electrolytes. Lubricious coatings are usually hydroxylic since they require a restrained adsorbed phase of water. Antistatic coatings are usually charged or charge-inducible as are ion-conductive coatings used in the construction of thin-film batteries. A combination of hydrophilicity and hydrophobicity may be a requirement in coatings which are used as primers or in selective adsorption applications such as chromatography. Formulation limitations may require that hydrophilicity is latent and becomes unmasked after application.

Factors affecting the intrinsic hydrolytic stability of silane treated surfaces are magnified when the water is drawn directly into the interface. Even pure silicon dioxide is ultimately soluble in water (at a level of 2-6ppm), but the kinetics, low concentration for saturation and phase separation, make this a negligible consideration in most applications. The equilibrium constant for the rupture of a Si-O-Si bond by water to two Si-OH bonds is estimated at  $10^{-3}$ . Since at minimum 3 Si-O-Si bonds must be simultaneously broken under equilibrium conditions to dissociate an organosilane from a surface, in hydrophobic environments the long-term stability is a minor consideration. Depending on the conditions of exposure to water of a hydrophilic coating, the long-term stability can be an important consideration. Selection of a dipodal, polypodal or other network forming silane as the basis for inducing hydrophilicity or as a component in the hydrophilic surface treatment is often obligatory.

#### **Range of Water Interaction with Surfaces**

interaction	description	surface example	measurement - parameter
low	superhydrophobic oleophobic lipophobic	fluorocarbon	contact angle
	oleophilic		water-sliding angle
	lipophilic hydrophobic	hydrocarbon	critical surface tension
moderate	polar hydrophilic	polymer oxide surface	heat of immersion
	hygroscopic	polyhydroxylic	water activity
strong	hydrogel film		equilibrium water absorption swell

(215) 547-1015

FAX: (215) 547-2484

# Reacting with the Substrate

**Leaving Groups** 

The reaction of an organofunctional silane with a surface bearing hydroxyl group results in a substitution reaction at silicon and the formation of the silvlated surface where the silicon is covalently attached to the surface via an oxygen linkage. This connection may be formed directly or in the presence of water through a reactive silanol intermediate. In general the reactivity of hydroxylated surfaces with organo-functional silanes decreases in the order: Si- $NR_2 > Si-Cl > Si-NH-Si > Si-O_2CCH_3 > Si-OCH_3 > Si-OCH_2CH_3$ . An analysis of the relevant bond energies indicates that the formation of the Si-O-surface bond is the driving force for the reaction under dry and aprotic conditions. Secondary factors contributing to the reactivity of organofunctional silanes with a surface are the volatility of the byproducts, the ability of the byproduct to hvdrogen bond with the hydroxyls on the surface, the ability of the byproduct to catalyze further reactions, e.g. HCl or acetic acid, and the steric bulk of the groups on the silicon atom.

Although they are not the most reactive organosilanes, the methoxy and ethoxysilanes are the most widely used organofunctional silanes for surface modification. The reasons for this include the fact that they are easily handled and the alcohol byproducts are non-corrosive and volatile. The methoxysilanes are capable of reacting with substrates under dry, aprotic conditions, while the less reactive ethoxysilanes require catalysis for suitable reactivity. The low toxicity of ethanol as a byproduct of the reaction favors the ethoxysilanes in many commercial applications. The vast majority of organofunctional silane surface treatments are performed under conditions in which water is a part of the reaction medium, either directly added or contributed by adsorbed water on the substrate or by atmospheric moisture.

## **Silane Requirements for Surface Coverage**

Hydrolytic Deposition – creating a minimum uniform coverage

The majority of surface modifications are affected by the hydrolytic deposition of trialkoxysilanes. Specific Wetting Surface (SWS) is a value determined empirically for the amount of silane required to obtain minimum uniform multilayer coverage on a substrate.

amount of silane (g) =  $\underline{\text{amount of substrate (g) x surface area of filler}}$  (m<sup>2</sup>/g) specific wetting surface

<b>Bond Dissociation Energies</b>			
Bond Dissociation Energy (kcal/mole)			
Me <sub>3</sub> Si-NMe <sub>2</sub>	98		
Me <sub>3</sub> Si-N(SiMe <sub>3</sub> ) <sub>2</sub>	109		
Me₃Si-Cl	117		
Me₃Si-OMe	123		
Me₃Si-0Et	122		
Me <sub>3</sub> Si-OSiMe <sub>3</sub>	136		

Common Leaving Groups				
Туре	Advantage	Disadvantage		
dimethylamine	reactive, volatile byproduct	toxic		
hydrogen chloride	reactive, volatile byproduct	corrosive		
silazane (NH <sub>3</sub> )	volatile	limited availability		
methoxy	moderate reactivity,	moderate toxicity		
	neutral byproduct			
ethoxy	low toxicity	lower reactivity		

Surface Area of Common Substrates		
Туре	m²/g	
E-Glass	0.10-0.12	
Silica, ground	1-2	
Silica, diatomaceous	1-3.5	
Calcium silicate	2.6	
Clay, kaolin	7	
Talc	7	
Silica, fumed	150-250	

Specific Wetting Surface (SWS) numbers are found throughout this brochure.

#### **Monolayer Deposition**

Monolayer deposition is a widely used term, but the definition of a monolayer is usually contextual. The simplest definition is that there is an attachment of a surface treatment molecule to every surface atom. However, coverage of this type is probably never the case. In general, monolayer coverage refers to the reaction of the surface treatment molecule with available hydroxyl groups on the surface, but this is also almost never achieved. For example, hydrated fumed silica has 4.4-4.6 –OH/nm². A high surface fumed silica has a surface area of 3.25 x 10<sup>20</sup> nm²/gram and thus 1.5 x 10<sup>21</sup> hydroxyls. If this is divided by Avogadro's number, 6.02 x 10<sup>23</sup>, 2.4 x10<sup>-3</sup> moles of silane are required to provide coverage on 1 gram of fumed silica. Monolayer bonding of a silane with a molecular weight of 200 would deposit 0.5 g silane per gram of silica. In fact, most monolayer depositions of silanes result in about 10% of the calculated requirement, i.e. 0.5g silane per gram of fumed silica.

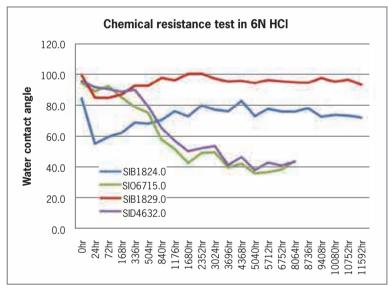
# **Special Topics**

#### **Dipodal Silanes**

Dipodal silanes are silanes employed in surface modification that possess two silicon atoms capable of bonding to surfaces through oxane bonds. Functional dipodal silanes and combinations of non-functional dipodal silanes with functional silanes have significant impact on substrate bonding, hydrolytic stability and mechanical strength of many composites systems. They possess enabling activity in many coatings, particularly primer systems and aqueous immersion applications. The effect is thought to be a result of both the increased crosslink density of the interphase and a consequence of the fact that the resistance to hydrolysis of dipodal materials (with the ability to form six bonds to a substrate) is estimated at close to 100,000 times greater than conventional coupling agents (with the ability to form only three bonds to a substrate).

#### **Dipodal vs Conventional Silanes**

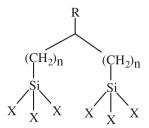
in acidic aqueous environments



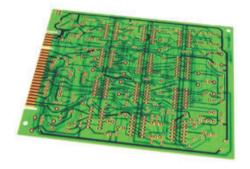
Glass surfaces treated with: bridged dipodal silane SIB1824.0 1,8-bis (triethoxysilyl)octane; conventional silane SI06715.0 n-octyltriethoxysilane; pendant dipodal silane SIB1829.0 1,2-bis(trimethoxysilyl)decane; conventional silane, SID4632.0 n-decyltriethoxysilane.



Hydrophobic coatings applied to antennas inhibit the formation of adsorbed water layers which become dielectric layers that absorb signals and cause high losses. If the water is in beads, the energy will be slightly diffracted because the water droplets have dimensions much less than a wavelength at these frequencies.



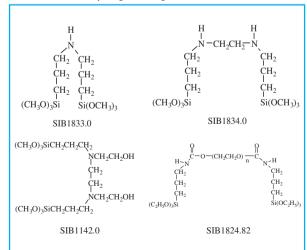
Multilayer printed circuit boards use dipodal silanes to maintain the integrity of the bond between metal and resins by reducing interfacial water adsorption.



#### Hydrophobic Dipodal Silanes

$$(C_2H_5O)_3Si-CH_2CH_2^-Si(OC_2H_5)_3\\SIB1817.0\\(C_2H_5O)_3Si-CH_2CH_2CH_2CH_2CH_2CH_2-Si(OC_2H_5)_3\\SIB1824.0\\(CH_3O)_3Si-CH_2CH_2\\CH_2CH_2-Si(OCH_3)_3\\Si(OCH_$$

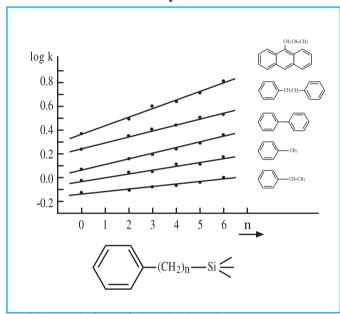
#### Hydrophilic Dipodal Silanes



#### **Linker Length**

An important factor in controlling the effectiveness and properties of a coupled system is the linker between the organic functionality and the silicon atom. The linker length imposes a number of physical property and reactivity limitations. The desirability of maintaining the reactive centers close to the substrate is most important in sensor applications, in heterogeneous catalysis, in fluorescent materials and in composite systems where the interfacing components are closely matched in modulus and coefficient of thermal expansion. On the other hand, inorganic surfaces can impose enormous steric constraints on the accessibility of organic functional groups in close proximity. If the linker length is long the functional group has greater mobility and can extend further from the inorganic substrate. This has important consequences if the functional group is expected to react with a single component in a multi-component organic or aqueous phase as found in homogeneous and phase transfer catalysis, biological diagnostics or liquid chromatography. Extended linker length is also important in oriented applications such as self-assembled monolayers (SAMs). The typical linker length is three carbon atoms, a consequence of the fact that the propyl group is both synthetically accessible and has good thermal stability.

# Effect of linker length on the separation of aromatic hydrocarbons



T. Den et al, in "Silanes, Surfaces, Interfaces" D. Leyden ed., 1986 p403.

#### Silanes with short linker length

# 

#### Silanes with extended linker length



#### **Combining Polarity and Non-Polarity in Silane Surface Treatments**

It may be desirable for a surface treatment to possess both polar groups and non-polar groups. The polarity may either embedded below a hydrocarbon tail (i.e. proximal to the surface) or tipped at the end of the hydrocarbon (i.e. proximal to the contacting phase).

#### **Tipped**

#### **Embedded**

Silane surface treatments with either tipped or embedded polarity provide an avenue to overcome traditional limitations imposed by surface energetics. They allow formation of surfaces that respond to solvent, electrical potential and thermal transitions by dramatically varying wettability. Silane treated substrates associated with a variety of multiphasic applications, including particle dispersion, reversed-phase HPLC and diagnostic assays can also take advantage of surfaces which combine polarity with non-polarity.

Comparative contact angle data of various silanes with polar substitution having degrees of hydrogen bonding and in which the polar groups are either embedded or are tipped along with hydrophobic and hydrophilic controls demonstrate interesting trends. Tipped polar silanes show higher contact angles with water than the embedded polar silanes, regardless of opportunities for hydrogen-bonding. The number of PEG units has relatively small impact on contact angle of the tipped silanes although an increase in number of PEG units does correlate to decreased water contact angle. PEG units embedded in silanes have a stronger effect on contact angle than PEG units in the tipped analogs. Hexadecane contact angle seems to be controlled by the number of carbon atoms in the carbon chain, although a step-change increase in contact angle is observed with C<sub>18</sub>-PEG silanes.

Polarity is generally associated with hydrophilicity. Non-polarity is generally associated with hydrophobicity. In the case of surface treatments, it may be that the term hydrophobic ("water-hating" or "water fearing") suggests a too simplistic explanation. It appears not so much that hydrocarbons hate water, but that water hates hydrocarbons. Hydrocarbons appear indifferent to water. In the case of alkylsilanes tipped with polar groups, water molecular interaction proceeds until interaction with the hydrocarbon. In the cases of alkylsilanes in which polar groups are embedded near the surface, the hydrocarbon poses only a small barrier to the access of water to the polar groups.

# Particle Dispersion Utilizing Silanes with Embedded Polarity

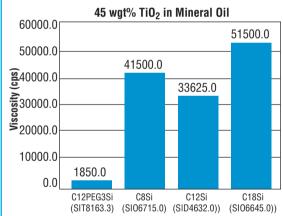
The incorporation of polar functionality into hydrocarbon substituted silanes can have dramatic effects on the dispersion of particles. Depending on the media, the appropriate mixed polarity surface treatment can improve dispersion, reduce viscosity or increase loading.

# Contact Angles of Water and Hexadecane on Silane Layers with Tipped and Embedded Polar Groups

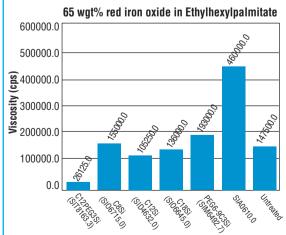
•		-	
Silane	Contact an	gle (degrees)	
<b>Hydrophobic control</b> Dodecyltriethoxysilane (SID4632.0)	Water 100	Hexadecane 21	
Hydrophilic tipped silanes (Methoxytriethyleneoxy)- trimethoxysilylundecanoate (SIM6493. Methoxyethoxyundecyltrichlorosilane (SIM6491.5)	.7) 74 73	7 5	
Hydrophilic embedded silanes Triethoxysilylpropoxy(triethyleneoxy)- octadecanoate Triethoxysilylpropoxy(triethyleneoxy)- dodecanoate (SIT8186.3) Triethoxysilylpropoxy(hexaethyleneoxy)- octadecanoate Triethoxysilylpropoxy(hexaethyleneoxy)- dodecanoate	42	28 6 28 3	
<b>Hydrophilic control</b> Methoxy(polyethyleneoxy) <sub>6-9</sub> - propyltrimethoxysilane (SIM6492.7)	16	17	

B. Arkles et al in "Silanes & Other Coupling Agents Vol 5, K. Mittal Ed. p.51 VSP (Brill) 2009.

#### Silane Surface Treated Particles – Effect on Rheology



Dispersion viscosity of different silane treated titanium dioxide pigment at 65% loading in mineral oil. DodecanoylPEG3silane (SIT8186.3) with embedded polarity provides lower viscosity than octyl-, dodecyl- and octadecylsilanes.



Dispersion viscosity of different silane treated iron oxide pigments at 65% loading in 2-ethylhexylpalmitate. DodecanoylPEG3silane (SIT8186.3) with embedded polarity provides lower viscosity than alkyl, polyethyleneoxide, and aminopropyl substituted silanes.

# Partition, Orientation and Self-Assembly in Bonded Phases

Chromatography

Octadecyl, cyanopropyl and branched tricocyl silanes provide bonded phases for liquid chromatography. Reverse-phase thin-layer chromatography can be accomplished by treating plates with dodecyltrichlorosilane.

#### **Liquid Crystal Displays**

The interphase can also impose orientation of the bulk phase. In liquid crystal displays, clarity and permanence of image are enhanced if the display can be oriented parallel or perpendicular to the substrate. The use of surfaces treated with octadecyl(3-(trimethoxysilyl)propyl) ammonium chloride (perpendicular) or methylaminopropyl-trimethoxysilane (parallel) has eliminated micromachining operations. The oriented crystalline domains often observed in reinforced nylons have also been attributed to orientation effects of the silane in the interphase.

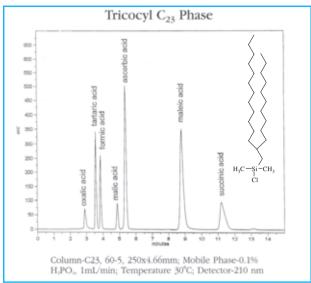
#### **Self-Assembled Monolayers (SAMs)**

A Self-Assembled Monolayer (SAM) is a one molecule thick layer of material that bonds to a surface in an ordered way as a result of physical or chemical forces during deposition. Silanes can form SAMs by solution or vapor phase deposition processes. Most commonly, chlorosilanes or alkoxysilanes are used and once deposition occurs a chemical (oxane) bond forms with the surface rendering a permanent modification of the substrate. Applications for SAMs include micro-contact printing, soft lithography, dip-pen nanolithography, anti-stiction coatings and orientation layers involved in nanofabrication of MEMs, fluidic microassemblies, semiconductor sensors and memory devices.

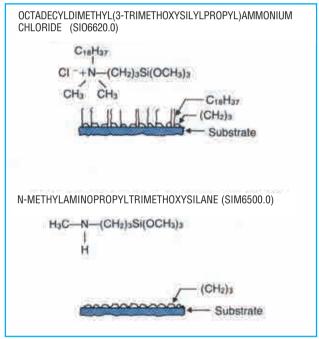
Common long chain alkyl silanes used in the formation of SAMs are simple hydrocarbon, fluoroalkyl and endgroup substituted silanes. Silanes with one hydrolyzable group maintain interphase structure after deposition by forming a single oxane bond with the substrate. Silanes with three hydrolyzable groups form siloxane (silsesquioxane) polymers after deposition, bonding both with each other as well as the substrate. For non-oxide metal substrates, silyl hydrides may be used, reacting with the substrate by a dehydrogenative coupling.

The perpendicular orientation of silanes with  $C_{10}$  or greater length can be utilized in micro-contact printing and other soft lithography methods. Here the silane may effect a simple differential adsorption, or if functionalized have a direct sensor effect.

# Normal Phase HPLC of Carboxylic Acids with a C<sub>23</sub>-Silane Bonded Phase

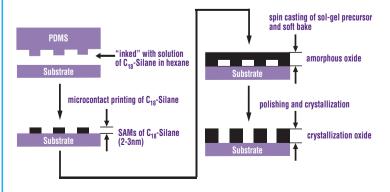


#### Orientation effects of silanes for passive LCDs



F. Kahn., Appl. Phys. Lett. 22, 386, 1973

#### **Micro-Contact Printing Using SAMs**



# **Modification of Metal Substrates**

The optimum performance of silanes is associated with siliceous substrates. While the use of silanes has been extended to metal substrates, both the effectiveness and strategies for bonding to these less-reactive substrates vary. Four approaches of bonding to metals have been used with differing degrees of success. In all cases, selecting a dipodal or polymeric silane is preferable to a conventional trialkoxy silane.

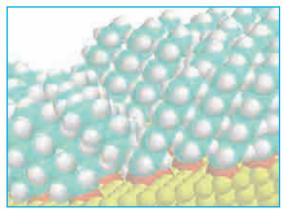
Metals that form hydrolytically stable surface oxides, e.g. aluminum, tin, titanium. These oxidized surfaces tend to have sufficient hydroxyl functionality to allow coupling under the same conditions applied to the siliceous substrates discussed earlier.

# Metals that form hydrolytically or mechanically unstable surface oxides, e.g. iron, copper, zinc.

These oxidized surfaces tend to dissolve in water leading to progressive corrosion of the substrate or form a passivating oxide layer without mechanical strength. The successful strategies for coupling to these substrates typically involve two or more silanes. One silane is a chelating agent such as a diamine, polyamine or polycarboxylic acid. A second silane is selected which has a reactivity with the organic component and reacts with the first silane by co-condensation. If a functional dipodal or polymeric silane is not selected, 10-20% of a non-functional dipodal silane typically improves bond strength.

Metals that do not readily form oxides, e.g. nickel, gold and other precious metals. Bonding to these substrates requires coordinative bonding, typically a phosphine, sulfur (mercapto), or amine functional silane. A second silane is selected which has a reactivity with the organic component. If a functional dipodal or polymeric silane is not selected, 10-20% of a non-functional dipodal silane typically improves bond strength.

SIP6926.2



Octysilane adsorbed on gold

figure courtesy of M. Banaszak-Holl

Metals that form stable hydrides, e.g. titanium, zirconium, nickel. In a significant departure from traditional silane coupling agent chemistry, the ability of certain metals to form so-called amorphous alloys with hydrogen is exploited in an analogous chemistry in which hydride functional silanes adsorb and then coordinate with the surface of the metal. Most silanes of this class possess only simple hydrocarbon substitution such as octylsilane. However they do offer organic compatibility and serve to markedly change wet-out of the substrate. Both hydride functional silanes and treated metal substrates will liberate hydrogen in the presence of base or with certain precious metals such as platinum and associated precautions must be taken.

(see p77.)

H<sub>2</sub>C=CH(CH<sub>2</sub>)<sub>8</sub>CH<sub>2</sub>Si -H
SIU9048.0 H

Coupling Agents for Metals*				
Metal	Class Screening Candidates			
Copper	Amine	SSP-060	SIT8398.0	
Gold	Sulfur Phosphorus	SIT7908.0 SID4558.0	SIP6926.2 SIB1091.0	
Iron	Amine Sulfur	SIB1834.0 SIB1824.6	WSA-7011 SIM6476.0	
Tin	Amine	SIB1835.5		
Titanium	Epoxy Hydride	SIG5840.0 SIU9048.0	SIE6668.0	
Zinc	Amine Carboxylate	SSP-060 SIT8402.0	SIT8398.0 SIT8192.6	

<sup>\*</sup>These coupling agents are almost always used in conjunction with a second silane with organic reactivity or a dipodal silane.

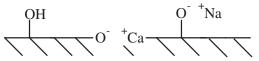
#### **Difficult Substrates**

Silane coupling agents are generally recommended for applications in which an inorganic surface has hydroxyl groups and the hydroxyl groups can be converted to stable oxane bonds by reaction with the silane. Substrates such as calcium carbonate, copper and ferrous alloys, and high phosphate and sodium glasses are not recommended substrates for silane coupling agents. In cases where a more appropriate technology is not available a number of strategies have been devised which exploit the organic functionality, film-forming and crosslinking properties of silane coupling agents as the primary mechanism for substrate bonding in place of bonding through the silicon atom. These approaches frequently involve two or more coupling agents.

Calcium carbonate fillers and marble substrates do not form stable bonds with silane coupling agents. Applications of mixed silane systems containing a dipodal silane or tetraethoxysilane in combination with an organofunctional silane frequently increases adhesion. The adhesive mechanism is thought to be due to the low molecular weight and low surface energy of the silanes which allows them initially to spread to thin films and penetrate porous structures followed by the crosslinking which results in the formation of a silica-rich encapsulating network. The silica-rich encapsulating network is then susceptible to coupling chemistry comparable to siliceous substrates. Marble and calciferous substrates can also benefit from the inclusion of anhydride-functional silanes which, under reaction conditions, form dicarboxylates that can form salts with calcium ions.

Metals and many metal oxides can strongly adsorb silanes if a chelating functionality such as diamine or dicarboxylate is present. A second organofunctional silane with reactivity appropriate to the organic component must be present. Precious metals such as gold and rhodium form weak coordination bonds with phosphine and mercaptan functional silanes.

High phosphate and sodium content glasses are frequently the most frustrating substrates. The primary inorganic constituent is silica and would be expected to react readily with silane coupling agents. However alkali metals and phosphates not only do not form hydrolytically stable bonds with silicon, but, even worse, catalyze the rupture and redistribution of silicon-oxygen bonds. The first step in coupling with these substrates is the removal of ions from the surface by extraction with deionized water. Hydrophobic dipodal or multipodal silanes are usually used in combination with organofunctional silanes. In some cases polymeric silanes with multiple sites for interaction with the substrate are used. Some of these, such as the polyethylenimine functional silanes can couple to high sodium glasses in an aqueous environment.



Substrates with low concentrations of non-hydrogen bonded hydroxyl groups, high concentrations of calcium, alkali metals or phosphates pose challenges for silane coupling agents.

#### **Removing Surface Impurities**

Eliminating non-bonding metal ions such as sodium, potassium and calcium from the surface of substrates can be critical for stable bonds. Substrate selection can be essential. Colloidal silicas derived from tetraethoxysilane or ammonia sols perform far better than those derived from sodium sols. Bulk glass tends to concentrate impurities on the surface during fabrication. Although sodium concentrations derived from bulk analysis may seem acceptable, the surface concentration is frequently orders of magnitude higher. Surface impurities may be reduced by immersion in 5% hydrochloric acid for 4 hours, followed by a deionized water rinse, and then immersion in deionized water overnight followed by drying.

Oxides with high isoelectric points can adsorb carbon dioxide, forming carbonates. These can usually be removed by a high temperature vacuum bake.

#### **Increasing Hydroxyl Concentration**

Hydroxyl functionalization of bulk silica and glass may be increased by immersion in a 1:1 mixture of 50% aqueous sulfuric acid: 30% hydrogen peroxide for 30 minutes followed by rinses in D.I. water and methanol and then air drying. Alternately, if sodium ion contamination is not critical, boiling with 5% aqueous sodium peroxodisulfate followed by acetone rinse is recommended.

1. K. Shirai et al, J. Biomed. Mater. Res. 53, 204, 2000.

#### **Catalyzing Reactions in Water-Free Environments**

Hydroxyl groups without hydrogen bonding react slowly with methoxy silanes at room temperature. Ethoxy silanes are essentially unreactive. The methods for enhancing reactivity include transesterification catalysts and agents which increase the acidity of hydroxyl groups on the substrate by hydrogen bonding. Transesterification catalysts include tin compounds such as dibutyldiacetoxytin and titanates such as titanium isopropoxide. Incorporation of transesterification catalysts at 2-3 weight % of the silane effectively promotes reaction and deposition in many instances. Alternatively, amines can be premixed with solvents at 0.01-0.5 weight % based on substrate prior or concurrent to silane addition. Volatile primary amines such as butylamine can be used, but are not as effective as tertiary amines such as benzyldimethylamine or diamines such as ethylenediamine. The more effective amines,

however, are more difficult to remove after reaction1.

1. S. Kanan et al, Langmuir, 18, 6623, 2002.

#### Hydroxylation by Water Plasma & Steam Oxidation

Various metals and metal oxides including silicon and silicon dioxide can achieve high surface concentrations of hydroxyl groups after exposure to  $H_2O/O_2$  in high energy environments including steam at  $1050^\circ$  and water plasma<sup>1</sup>.

 N. Alcanter et al, in "Fundamental & Applied Aspects of Chemically Modified Surfaces" ed. J. Blitz et al, 1999, Roy. Soc. Chem., p212.

# **Applying Silanes**

**Deposition from aqueous alcohol** solutions is the most facile method for preparing silylated surfaces. A 95% ethanol-5% water solution is adjusted to pH 4.5-5.5 with acetic acid. Silane is added with stirring to yield a 2% final concentration. Five minutes should be allowed for hydrolysis and silanol formation. Large objects, e.g. glass plates, are dipped into the solution, agitated

Fig. 1 Reactor for slurry treatment of powders. Separate filtration and drying steps are required.

gently, and removed after 1-2 minutes. They are rinsed free of excess materials by dipping briefly in ethanol. Particles, e.g. fillers and supports, are silylated by stirring them in solution for 2-3 minutes and then decanting the solution. The particles are usually rinsed twice briefly with ethanol. Cure of the silane layer is for 5-10 mins at  $110^{\circ}$ C or 24 hours at room temperature (<60% relative humidity).

**Deposition from aqueous solution** is employed for most commercial fiberglass systems. The alkoxysilane is dissolved at 0.5-2.0% concentration in water. For less soluble silanes, 0.1% of a non-ionic surfactant is added prior to the silane and an emulsion rather than a solution is prepared. The solution is adjusted to pH 5.5 with acetic acid. The solution is either sprayed onto the substrate or employed as a dip bath. Cure is at 110-120°C for 20-30 minutes.

Stability of aqueous silane solutions varies from 2-12 hours for the simple alkyl silanes. Poor solubility parameters limit the use of long chain alkyl and aromatic silanes by this method. Distilled water is not necessary, but water containing fluoride ions must be avoided.

**Bulk deposition onto powders,** e.g. filler treatment, is usually accomplished by a spray-on method. It assumes that the total amount of silane necessary is known and that sufficient adsorbed moisture is present on the filler to cause hydrolysis of the silane. The silane is prepared as a 25% solution in alcohol. The powder is placed in a high intensity solid mixer, e.g. twin cone mixer with

**Fig. 2** Vacuum tumble dryers can be used for slurry treatment of powders.

intensifier. The methods are most effective. If the filler is dried in trays, care must be taken to avoid wicking or skinning of the top layer of treated material by adjusting heat and air flow.

**Integral blend methods** are used in composite formulations. In this method the silane is used as a simple additive. Composites can be prepared by the addition of alkoxysilanes to dry-blends of polymer and filler prior to compounding. Generally 0.2 to 1.0 weight percent of silane (of the total mix) is dispersed by spraying the silane in an alcohol carrier onto a preblend. The addition of the silane to non-dispersed filler is not desirable in this technique since it can lead to agglomeration. The mix is dry-blended briefly and then melt compounded. Vacuum devolatization of byproducts of silane reaction during melt compounding is necessary to achieve optimum properties. Properties are sometimes enhanced by adding 0.5-1.0% of tetrabutyl titanate or benzyldimethylamine to the silane prior to dispersal.

Anhydrous liquid phase deposition of chlorosilanes, methoxysilanes, aminosilanes and cyclic azasilanes is preferred for small particles and nano-featured substrates. Toluene, tetrahydrofuran or hydrocarbon solutions are prepared containing 5% silane. The mixture is refluxed for 12-24 hours with the substrate to be treated. It is washed with the solvent. The solvent is then removed by air or explosion-proof oven drying. No further cure is necessary. This reaction involves a direct nucleophilic displacement of the silane chlorines by the surface silanol. If monolayer deposition is desired, substrates should be predried at 150°C for 4 hours. Bulk deposition results if adsorbed water is present on the substrate. This method is cumbersome for large scale preparations and rigorous controls must be established to ensure reproducible results. More reproducible coverage is obtained with monochlorosilanes.

**Chlorosilanes** can also be deposited from alcohol solution. Anhydrous alcohols, particularly ethanol or isopropanol are preferred. The chlorosilane is added to the alcohol to yield a 2-5% solution. The chlorosilane reacts with the alcohol producing an alkoxysilane and HCl. Progress of the reaction is observed by halt of HCl evolution. Mild warming of the solution (30-40°C) promotes completion of the reaction. Part of the HCl reacts with the alcohol to produce small quantities of alkyl halide and water. The water causes formation of silanols from alkoxysilanes. The silanols condense on the substrate. Treated substrates are cured for 5-10 mins. at 110°C or allowed to stand 24 hours at room temperature.







**Fig. 3** Twin-cone blenders with intensive mixing bars are used for bulk deposition of silanes onto powders.

# **Applying Silanes**

#### **Vapor Phase Deposition**

Silanes can be applied to substrates under dry aprotic conditions by chemical vapor deposition methods. These methods favor monolayer deposition. Although under proper conditions almost all silanes can be applied to substrates in the vapor phase, those with vapor pressures >5 torr at 100°C have achieved the greatest number of commercial applications. In closed chamber designs, substrates are supported above or adjacent to a silane reservoir and the reservoir is heated to sufficient temperature to achieve 5mm vapor pressure. Alternatively, vacuum can be applied until silane evaporation is observed. In still another variation the silane can be prepared as a solution in toluene, and the toluene brought to reflux allowing sufficient silane to enter the vapor phase through partial pressure contribution. In general, substrate temperature should be maintained above 50° and below 120° to promote reaction. Cyclic azasilanes deposit the quickest-usually less than 5 minutes. Amine functional silanes usually deposit rapidly (within 30 minutes) without a catalyst. The reaction of other silanes requires extended reaction times, usually 4-24 hours. The reaction can be promoted by addition of catalytic amounts of amines.

#### Spin-On

Spin-On applications can be made under hydrolytic conditions which favor maximum functionalization and polylayer deposition or dry conditions which favor monolayer deposition. For hydrolytic deposition 2-5% solutions are prepared (see deposition from aqueous alcohol). Spin speed is low, typically 500 rpm. Following spin-deposition a hold period of 3-15 minutes is required before rinse solvent. Dry deposition employs solvent solutions such as methoxypropanol or ethyleneglycol monoacetate (EGMA). Aprotic systems utilize toluene or THF. Silane solutions are applied at low speed under a nitrogen purge. If strict monolayer deposition is preferred, the substrate should be heated to 50°. In some protocols, limited polylayer formation is induced by spinning under an atmospheric ambient with 55% relative humidity.

#### **Spray application**

Formulations for spray applications vary widely depending on end-use. They involve alcohol solutions and continuously hydrolyzed aqueous solutions employed in architectural and masonry applications. The continuous hydrolysis is effected by feeding mixtures of silane containing an acid catalyst such as acetic acid into a water stream by means of a venturi (aspirator). Stable aqueous solutions (see water-borne silanes), mixtures of silanes with limited stability (4-8 hours) and emulsions are utilized in textile and fiberglass applications. Complex mixtures with polyvinyl acetates or polyesters enter into the latter applications as sizing formulations.

Figure 4.

Apparatus for vapor phase silylation.

Pressure
Gauge
Temperature
Controlled
Chamber
Vapor Injection Ports

Wassum Port
Vacuum Port
Precision Delivery System
Precision Delivery System

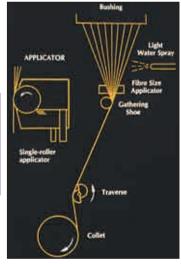
Figure 5. Spin-coater for deposition on wafers.



Figure 6. Spray application of silanes on large structures.



Figure 7. Spray & contact roller application of silanes on fiberglass.



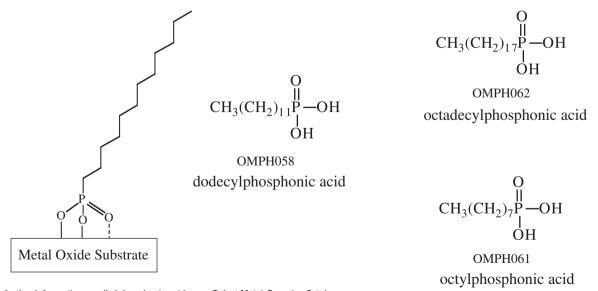
#### **Biomimetic Silane Surface Treatments**

In addition to the direct metabolic and structural roles played by many biomolecules, they can also be involved in control of *in vivo* hydrophilic-lipophilic balance and specific adsorptive interactions with other biomolecules. Biomimetic silanes offer an opportunity to modify surfaces to impart a desired level of hydrophilicity and control biomolecule adsorption.

$$CH_3 \\ O = C \\ O = C$$

#### **Alkylphosphonic Acids**

Alkylphosphonic acids are utilized as hydrophobic coatings for a variety of non-siliceous, native oxide surfaces of metals such as iron, steel, tin, aluminum and copper. Alkylphosphonic acids can react under ambient conditions to form adherent, alkane chain ordered films. They have advantages over alkylsilanes when a metal-oxide substrate does not form a hydrolytically stable silicon-oxygen-metal bond. Alkylphosphonic acids are generally deposited from dilute solutions (0.25-0.50 wgt %) in moderately polar solvents such as toluene, tetrahydrofuran and ethanol. The deposition results in self-assembled monolayers (SAMs) in which it is generally considered that two direct bonds are formed with the surface through oxygen-metal linkages and the third remaining oxygen is coordinated to the surface.



For further information on alkylphosphonic acids, see Gelest Metal-Organics Catalog.

# **Hydrophobic Silane Selection Guide**

Hydrophobic silanes employed in surface moodification form the following major categories:

Methyl-Silanes	.22
Linear Alkyl-Silanes	.24
Branched Alkyl-Silanes	.26
Aromatic-Silanes	.28
Fluorinated Alkyl-Silanes	.30
Dialkyl-Silanes	.30

#### **Methyl-Silanes** very hydrophobic, hydrolysates stable to 425°C, acceptable performance to 600°C reported, volatile

#### 3 Hydrolyzable Groups

Hydrolyzable Groups	Product Code	Product Name
chloro methoxy ethoxy propoxy methoxyalkoxy acetoxy dimethylamine other amine silazane (NH) oxime	SIM6520.0 SIM6560.0 SIM6555.0 SIM6579.0 SIM6585.0 SIM6519.0 SIT8712.0 SIT8710.0	methyltrichlorosilane methyltrimethoxysilane methyltriethoxysilane methyltri-n-propoxysilane methyltris(methoxyethoxy)silane methyltriacetoxysilane tris(dimethylamino)methylsilane tris(cyclohexylamino)methylsilane methyltris(methylethylketoximino)silane

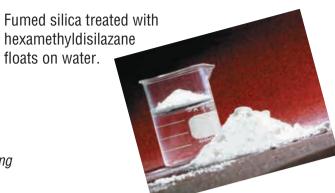
## Methyl-SiloxanylSilanes

### 3 or more Hydrolyzable Groups

Hydrolyzable Groups    Froduct Code			, ,	•
chloro ethoxy acetoxy  ilicon atom compounds  chloro methoxy ethoxy chloro methoxy ethoxy ethoxy ethoxy ethoxy ethoxy ethoxy ency ethoxy exponential exponen		Hydrolyzable Groups	Product Code	Product Name
ethoxy acetoxy  illicon atom compounds  Chloro methoxy ethoxy chloro  comeric polysiloxanes  Chloro methoxy ethoxy amine/silazane silanol  cected specialties  SIT7095.0 tetraethoxy-1,3-dimethyldisiloxane	2 silicon atom	compounds		
chloro methoxy ethoxy chloro  gomeric polysiloxanes  chloro methoxy ethoxy ethoxy amine/silazane silanol gected specialties  chloro methoxy slM6560.2 methyltrimethoxysilane, oligomeric hydrolysate methyltrimethoxysilane, oligomeric hydrolysate		ethoxy		
methoxy ethoxy chloro  gomeric polysiloxanes  chloro methoxy ethoxy ethoxy amine/silazane silanol  dected specialties  SIM6560.2 methyltrimethoxysilane, oligomeric hydrolysate methyltrimethoxysilane, oligomeric hydrolysate	3 silicon atom	compounds		
chloro methoxy ethoxy amine/silazane silanol  silacted specialties  SIM6560.2 methyltrimethoxysilane, oligomeric hydrolysate methyltrimethoxysilane, oligomeric hydrolysate		methoxy ethoxy		
methoxy SIM6560.2 methyltrimethoxysilane, oligomeric hydrolysate ethoxy amine/silazane silanol ected specialties	oligomeric poly	vsiloxanes		
		methoxy ethoxy amine/silazane	SIM6560.2	methyltrimethoxysilane, oligomeric hydrolysate
SID4236.0 dimethyltetramethoxydisiloxane	selected specia			
			SID4236.0	dimethyltetramethoxydisiloxane



**Pigments** treated with hydrophobic silanes resist agglomeration in highly polar vehicle and film-forming compositions such as those used in nail polish.



#### 2 Hydrolyzable Groups

#### 1 Hydrolyzable Group

Product Code	Product Name	Product Code	Product Name
SID4120.0	dimethyldichlorosilane	SIT8510.0	trimethylchlorosilane
SID4123.0	dimethyldimethoxysilane	SIT8566.0	trimethylmethoxysilane
SID4121.0	dimethyldiethoxysilane	SIT8515.0	trimethylethoxysilane
		SIT8568.0	trimethyl-n-propoxysilane
		SIM6492.8	methoxypropoxytrimethylsilane
SID4076.0	dimethyldiacetoxysilane	SIA0110.0	acetoxytrimethylsilane
SIB1072.0	bis(dimethylamino)dimethylsilane	SID3605.0	dimethylaminotrimethylsilane
SIB1068.0	bis(diethylamino)dimethylsilane	SID3398.0	diethylaminotrimethylsilane
SIH6102.0	hexamethylcyclotrisilazane	SIH6110.0	hexamethyldisilazane
			·

## 2 Hydrolyzable Groups

## 1 Hydrolyzable Group

Product Code	Product Name	Product Code	Product Name
SID3372.0 SIT7534.0	dichlorotetramethyldisiloxane tetramethyldiethoxydisiloxane	SIP6717.0	pentamethylacetoxydisiloxane
SID3360.0 SID3394.0 SIB1837.0	dichlorohexamethyltrisiloxane 1,5-diethoxyhexamethyltrisiloxane bis(trimethylsiloxy)dichlorosilane	SIB1843.0	bis(trimethylsiloxy)methylmethoxysilane
DMS-K05 DMS-XM11 DMS-XE11 DMS-N05 DMS-S12	chlorine terminated polydimethylsiloxane methoxy terminated polydimethylsiloxane ethoxy terminated polydimethylsiloxane dimethylamine terminated polydimethylsiloxane silanol terminated polydimethylsiloxane		Space Shuttle tiles are treated with dimethylethoxysilane to reduce water absorption.
		SID4125.0	dimethylethoxysilane



# **Hydrophobic Silane Selection Guide**

Linea	r Alkyl-Sila	nes		
			3 Hydrolyzable Groups	
	H	ydrolyzable Groups		Product Name
$C_2$	hydrophobic, treatm	ent for microporous mine	eral powders used as fillers for plastics	
		chloro	SIE4901.0	ethyltrichlorosilane
		methoxy	SIE4901.4	ethyltrimethoxysilane
		ethoxy acetoxy	SIE4901.2 SIE4899.0	ethyltriethoxysilane ethyltriacetoxysilane
C <sub>3</sub>	hydrophobic treatm		eral powders used as fillers for plastics	emymacetoxysnane
-0	,	chloro	SIP6915.0	propyltrichlorosilane
		methoxy	SIP6918.0	propyltrimethoxysilane
		ethoxy	SIP6917.0	propyltriethoxysilane
0	na a da vata bu dva n b a b	amine/silazane	versa etwietuwe minimal evenue enmastikilik.	
C <sub>4</sub>	moderate hydrophot	chloro	orous structures, minimal organic compatibility SIB1982.0	n-butyltrichlorosilane
		methoxy	SIB1988.0	n-butyltrimethoxysilane
		ethoxy	SIB1986.0	n-butyltriethoxysilane
		amine/silazane	0.2.000.0	Zadymiomoryonamo
C <sub>5</sub>	moderate hydrophol	picity with minimal organi	ic compatibility	
		chloro	SIP6720.0	pentyltrichlorosilane
		ethoxy	SIP6720.2	pentyltriethoxysilane
C <sub>6</sub>	moderate hydrophol	picity with moderate orga	•	
		chloro	SIH6167.0 SIH6169.5	hexyltrichlorosilane
		methoxy ethoxy	SIH6168.5 SIH6167.5	hexyltrimethoxysilane hexyltriethoxysilane
C <sub>7</sub>	moderate hydrophol	picity with moderate orga		noxytti icti oxysiiane
•/	moderate ny dropnes	chloro	SIH5846.0	heptyltrichlorosilane
C <sub>8</sub>	hydrophobic with mo		oility - generally most economical	noptylinomorodiumo
	J. J. Line	chloro	SI06713.0	octyltrichlorosilane
		methoxy	SI06715.5	octyltrimethoxysilane
		ethoxy	SI06715.0	octyltriethoxysilane
		amine silazane (NH)		
C <sub>10</sub>	hydronhohic concer	ntrates on surface of micr	ronorous structures	
010	nydrophobio, concor	chloro	SID2663.0	decyltrichlorosilane
		methoxy	SID2670.0	decyltrimethoxysilane
		ethoxy	SID2665.0	decyltriethoxysilane
C <sub>11</sub>	hydrophobic, concer		roporous structures, forms SAMs	
0	la alama ka kila a a a a a	chloro	SIU9050.0	undecyltrichlorosilane
C <sub>12</sub>	nyaropnobic, concer	chloro	roporous structures, forms SAMs SID4630.0	dodecyltrichlorosilane
		methoxy	SID4635.0	dodecyltrimethoxysilane
		ethoxy	SID4632.0	dodecyltriethoxysilane
C <sub>14</sub>	hydrophobic, concer	•	roporous structures, forms SAMs	
		chloro	SIT7093.0	tetradecyltrichlorosilane
C <sub>16</sub>	forms hydrophobic a		quid a room temperature, forms SAMs	
		chloro	SIH5920.0	hexadecyltrichlorosilane
		methoxy	SIH5925.0 SIH5922.0	hexadecyltrimethoxysilane hexadecyltriethoxysilane
C	farma buduanhahia	ethoxy		nexadecylinethoxysharie
C <sub>18</sub>	TOTTIS HYDROPHODIC 8	and oleophilic coatings all chloro	lowing full miscibility with parafinic materials, forms SAMs SIO6640.0	octadecyltrichlorosilane
		methoxy	\$106645.0	octadecyltrimethoxysilane
		ethoxy	SI06642.0	octadecyltriethoxysilane
		amine	SI06648.0	octadecyltris(dimethylamino)silane
		proprietary	SIS6952.0/PPI-GC18	Siliclad®/Glassclad® 18
C <sub>20</sub>	forms hydrophobic a		olid at room temperature	de la Referencia de la Constancia de la
		chloro	SIE4661.0	eicosyltrichlorosilane
C <sub>20-24</sub>	forms hydrophobic		solid at room temperature	de con lledelle a 2 de la constante de la cons
		chloro	SID4621.0	docosyltrichlorosilane blend
	,	ethoxy	SID4622.09	docosyltriethoxysilane blend
C <sub>26</sub> -C <sub>34</sub>	forms hydrophobic		solid at room temperature	tuiggant ultuighlassa illassa hilassa
		chloro	SIT8048.0	triacontyltrichlorosilane blend



2 Hydrolyzab Product Code	Product Name	7 / Product Code	Hydrolyzable Group Product Name
SIE4896.0	ethylmethyldichlorosilane	SIE4892.0	ethyldimethylchlorosilane
SIP6912.0 SIP6914.0	propylmethyldichlorosilane propylmethyldimethoxysilane	SIP6910.0 SIP6911.0	propyldimethylchlorosilane propyldimethylmethoxysilane
		SID4591.0	dipropyltetramethyldisilazane
SIB1972.0	butylmethyldichlorosilane	SIB1934.0	n-butyldimethylchlorosilane
		SIB1937.0	n-butyldimethyl(dimethylamino)silane
SIP6719.9	pentylmethyldichlorosilane		
SIH6165.6	hexylmethyldichlorosilane		
			octyldimethylchlorosilane
SIH5845.0	heptylmethyldichlorosilane		
SI06712.0	octylmethyldichlorosilane	SI06711.0 SI06711.1	octyldimethylchlorosilane octyldimethylmethoxysilane
SI06712.2	octylmethyldiethoxysilane	SI06711.3 SID4404.0	octyldimethyl(dimethylamino)silane dioctyltetramethyldisilazane
SID2662.0	decylmethyldichlorosilane	SID2660.0	decyldimethylchlorosilane
010 4000 0		010 4007 0	
SID4628.0 SID4629.0	dodecylmethyldichlorosilane dodecylmethyldiethoxysilane	SID4627.0	dodecyldimethylchlorosilane
31D4029.0	douecyfffichryfdiethoxysfiane		
SI06625.0 SI06629.0	octadecylmethyldichlorosilane octadecylmethyldimethoxysilane	SI06615.0 SI06618.0	octadecyldimethylchlorosilane octadecyldimethylmethoxysilane
SI06627.0	octadecylmethyldiethoxysilane	SI06617.0	octadecyldimethyl(dimethylamino)silane
SID4620.0	docosylmethyldichlorosilane blend		
0.2 .320.0	2.2005 Signatura di Silano di		
		SIT8045.0	triacontyldimethylchlorosilane blend

(215) 547-1015 FAX: (215) 547-2484 www.gelest.com



# **Hydrophobic Silane Selection Guide**

# Branched and Cyclic Alkyl-Silanes

3 Hydrolyzable Groups

		. Ty di oty zabio di oapo		
	Hydrolyzable Groups	Product Code	Product Name	
C <sub>3</sub>				
	chloro			
C <sub>4</sub>				
	chloro methoxy ethoxy chloro	SII6453.0 SII6453.7 SII6453.5 SIB1985.0	isobutyltrichlorosilane isobutyltrimethoxysilane isobutyltriethoxysilane t-butyltrichlorosilane	
C <sub>5</sub>				
	chloro methoxy	SIC2555.0 SIC2557.0	cyclopentyltrichlorosilane cyclopentyltrimethoxysilane	
C <sub>6</sub>				
	chloro ethoxy chloro chloro methoxy	SID4069.0 SID4068.4 SIT7906.6 SIC2480.0 SIC2482.0	(3,3-dimethylbutyl)trichlorosilane (3,3-dimethybutyl)triethoxysilane thexyltrichlorosilane cyclohexyltrichlorosilane cyclohexyltrimethoxysilane	
C <sub>7</sub>	norbornene			
	chloro chloro	SIB0997.0 SIC2470.0	bicycloheptyltrichlorosilane (cyclohexylmethyl)trichlorosilane	
C <sub>8</sub>				
	chloro methoxy ethoxy chloro	SII6457.0 SII6458.0 SII6453.5 SIC2490.0	isooctyltrichlorosilane isooctyltrimethoxysilane isooctyltriethoxysilane cyclooctyltrichlorosilane	
C <sub>10</sub>				
C <sub>12</sub>				
C		SIA0325.0	adamantylethyltrichlorosilane	
C <sub>16</sub>		SIT8162.4	7-(trichlorosilylmethyl)pentadecane	
C <sub>18</sub>	silahydrocarbon			
	chloro	SID4401.5	(di-n-octylmethylsilyl)ethyltrichlorosilane	
C <sub>24</sub>	chloro			
C <sub>28</sub>	officion and a second a second and a second			
28	chloro	SIT8162.0	13-(trichlorosilylmethyl)heptacosane	



P	2 Hydroly Product Code	/zable Groups Product Name	Product Code	1 Hydrolyzable Group Product Name	5
CI	116463.0	ioonranylmathyldichlarooilana	SII6462.0	icopropyldimethylobleropilane	t
31	110403.0	isopropylmethyldichlorosilane	3110402.0	isopropyldimethylchlorosilane	
SI	116452.8	isobutylmethyldimethoxysilane	SII6452.5	isobutyldimethylchlorosilane	
SI	IB1972.2	t-butylmethyldichlorosilane	SIB1935.0	t-butyldimethylchlorosilane	
			SID4065.0	(3,3-dimethylbutyl)dimethylchlorosilane	
	IC2468.0 IC2469.0	cyclohexylmethyldichlorosilane cyclohexylmethyldimethoxysilane	SIT7906.0 SIC2465.0	thexyldimethylchlorosilane cyclohexyldimethylchlorosilane	
			SIB0994.0	bicycloheptyldimethylchlorosilane	
			SII6456.6	isooctyldimethylchlorosilane	
			SID4074.0	(dimethylchlorosilyl)methylpinane	
			SID4401.0	(di-n-octylmethylsilyl)ethyldimethylchlorosilane	
			SIC2266.5	11-(chlorodimethylsilylmethyl)tricosane	
			SIC2266.0	13-(chlorodimethylsilylmethyl)heptacosane	

Isobutyltriethoxysilane solutions in ethanol are applied by spray to protect architecture.



# **Hydrophobic Silane Selection Guide**

3 Hydrolyzable Groups					
	Hydrolyzable Groups	Product Code	Product Name		
spacer atoms = 0	Moderate hydrophobicity,	hydrolysates stable to 325° C; UV, radia	ation resistant		
	chloro methoxy ethoxy acetoxy oxime/amine	SIP6810.0 SIP6822.0 SIP6821.0 SIP6790.0 SIP6826.5	phenyltrichlorosilane phenyltrimethoxysilane phenyltriethoxysilane phenyltriacetoxysilane phenyltris(methylethylketoximino)silane		
spacer atoms = 1	OXIIIIO/ AIIIIIIIO	OH 0020.0	prioriyitrio(motriyiotryiitotoxiiriiiro)oliario		
	chloro ethoxy chloro	SIB0970.0 SIB0971.0 SIP6813.0	benzyltrichlorosilane benzyltriethoxysilane 1-phenyl-1-trichlorosilylbutane		
spacer atoms = 2	More hydrophobic, acid re				
	chloro methoxy amine/silazane	SIP6722.0 SIP6722.6	phenethyltrichlorosilane phenethyltrimethoxysilane		
spacer atoms = 3					
	chloro	SIP6744.6	(3-phenylpropyl)trichlorosilane		
spacer atoms = 4	chloro methoxy chloro	SIP6724.9 SIP6724.92 SIP6723.3	4-phenylbutyltrichlorosilane 4-phenylbutyltrimethoxysilane phenoxypropyltrichlorosilane		
spacer atoms > 4					
	chloro chloro chloro	SIP6736.4 SIP6723.4	phenoxyundecyltrichlorosilane phenylhexyltrichlorosilane		
Substituted	Phenyl- and Pher	vylalkyl-Silanes			
	i nenyi ana i nei	iyiaikyi-Silailes			
		nenyl, peroxide crosslinkable			
spacer atoms = 0	More hydrophobic than pl chloro methoxy	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0	p-tolyltrichlorosilane p-tolyltrimethoxysilane		
	More hydrophobic than pl chloro methoxy Greater compatibility	nenyl, peroxide crosslinkable SIT8040.0			
spacer atoms = 0 spacer atoms = 2	More hydrophobic than pl chloro methoxy	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0			
spacer atoms = 0	More hydrophobic than please chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro	senyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0	p-tolyltrimethoxysilane ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane		
spacer atoms = 0 spacer atoms = 2	More hydrophobic than please chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5	p-tolyltrimethoxysilane ethylphenethyltrimethoxysilane		
spacer atoms = 0  spacer atoms = 2  spacer atoms = 3	More hydrophobic than please chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro	senyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0 SIM6492.5	ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane		
spacer atoms = 0  spacer atoms = 2  spacer atoms = 3	More hydrophobic than please chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro chloro  lanes Forms high refractive methoxy	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0 SIM6492.5 index coatings SIN6597.0	ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane  3-(p-methoxyphenyl)propyltrichlorosilane  1-naphthyltrimethoxysilane		
spacer atoms = 0  spacer atoms = 2  spacer atoms = 3  Naphthyl-Sil	More hydrophobic than ple chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro  chloro  lanes Forms high refractive methoxy chloro	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0 SIM6492.5 index coatings	ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane  3-(p-methoxyphenyl)propyltrichlorosilane		
spacer atoms = 0  spacer atoms = 2  spacer atoms = 3  Naphthyl-Sil	More hydrophobic than please chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro chloro  lanes Forms high refractive methoxy	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0 SIM6492.5 index coatings SIN6597.0	ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane  3-(p-methoxyphenyl)propyltrichlorosilane  1-naphthyltrimethoxysilane		
spacer atoms = 0  spacer atoms = 2  spacer atoms = 3  Naphthyl-Sill  Specialty Ar	More hydrophobic than ple chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro  chloro  lanes Forms high refractive methoxy chloro	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0 SIM6492.5 index coatings SIN6597.0	ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane  3-(p-methoxyphenyl)propyltrichlorosilane  1-naphthyltrimethoxysilane		
spacer atoms = 0  spacer atoms = 2  spacer atoms = 3  Naphthyl-Sil	More hydrophobic than ple chloro methoxy Greater compatibility methyl/chloro ethyl/chloro ethyl/methoxy t-butyl/chloro  chloro  lanes Forms high refractive methoxy chloro	nenyl, peroxide crosslinkable SIT8040.0 SIT8042.0 with styrenics, acrylics SIE4897.5 SIB1973.0 SIM6492.5 index coatings SIN6597.0	ethylphenethyltrimethoxysilane p-(t-butyl)phenethyltrichlorosilane  3-(p-methoxyphenyl)propyltrichlorosilane  1-naphthyltrimethoxysilane		



2 Нус	drolyzable Groups	1 H	lydrolyzable Group
Product Code	Product Name	Product Code	Product Name
0100700 0	ah an da adh dilah an allan	0100700	about 12 and building the co
SIP6738.0 SIP6740.0	phenylmethyldichlorosilane phenylmethyldimethoxysilane	SIP6728.0	phenyldimethylchlorosilane
SIP6739.0	phenylmethyldiethoxysilane	SIP6728.4	phenyldimethylethoxysilane
SIP6736.8	phenylmethylbis(dimethylamino)silane		
SIP6738.5	1-phenyl-1-methyldichlorosilylbutane	SIB0962.0	benzyldimethylchlorosilane
SIP6721.5	phenethylmethyldichlorosilane	SP6721.0	phenethyldimethylchlorosilane
SIM6512.5	(2-methyl-2-phenethyl) methydlichlorosilane	SIP6721.2	phenethyldimethyl(dimethylamino)silane
SIP6744.0	(3-phenylpropyl)methyldichlorosilane	SIP6743.0	(3-phenylpropyl)dimethylchlorosilane
SIP6724.8	4-phenylbutylmethyldichlorosilane	SIP6724.7	4-phenylbutyldimethylchlorosilane
SIP6723.25	phenoxypropylmethyldichlorosilane	SIP6723.2	phenoxypropyldimethylchlorosilane
		SIP6736.3 SIP6729.5	(6-phenylhexyl)dimethylchlorosilane (12-phenyldodecyl)dimethylchlorosilane
		3170729.5	(12-phenyldodecyr)diffiethylchlorosilane
SIT8035.0 SIT8035.6	p-tolylmethydichlorosilane p-tolylmethyldimethoxysilane	SIT8030.0	p-tolyldimethylchlorosilane
SIM6511.0	(p-methylphenethyl)methyldichlorosilane	SIE4897.2	m,p-ethylphenethyldimethylchlorosilane
		SIB1972.5	p-(t-butyl)phenethyldimethylchlorosilane
SIM6492.4	3-(p-methoxyphenyl)propylmethyldichlorosilane		
		0100700.0	
		SIP6723.0	m-phenoxyphenyldimethylchlorosilane
		SIN6598.0	p-nonylphenoxypropyldimethylchlorosilane



# **Hydrophobic Silane Selection Guide**

		3 Hydrolyzable Grou	ins	
	Hydrolyzable Groups	Product Code	Product Nan	ne
C <sub>3</sub>	Moderately polar hydrophob		T Toudot Hull	
03	chloro	SIT8371.0	(2.2.2-trifluoron	ropyl)trichlorosilane
	methoxy	SIT8372.0		opyl)trimethoxysilane
	amine/silazane	511007 E.0	(0,0,0 timuoropi	opyrja i i i ozijonano
C <sub>6</sub>	Hydrophobic films			
	chloro	SIN6597.6	nonafluorohexyl	richlorosilane
	methoxy	SIN6597.7	nonafluorohexyli	
	ethoxy	SIN6597.65	nonafluorohexyli	
•	amino/silazane	SIN6597.4	nonatiuoronexyi	ris(dimethylamino)silane
C <sub>8</sub>	Hydrophobic, oleophobic file		/hildredlines d	4.0.0 Ashashaadaa aatal\\ta'ahlaaa a'laaa
	chloro	SIT8174.0		1,2,2-tetrahydrooctyl)trichlorosilane
	methoxy ethoxy	SIT8176.0 SIT8175.0		1,2,2-tetrahydrooctyl)trimethoxysilane 1,2,2-tetrahydrooctyl)triethoxysilane
C <sub>10</sub>	•	n extremely low surface energy	(triucoariuoro-1,	1,2,2-tetranyurooctyr)trietrioxysiiarie
<b>V</b> 10	chloro	SIH5841.0	(hentadecafluoro	-1,1,2,2-tetrahydrodecyl)trichlorosilane
	methoxy	SIH5841.5		-1,1,2,2-tetrahydrodecyl)trimethoxysilane
	ethoxy	SIH5841.2		-1,1,2,2-tetrahydrodecyl)triethoxysilane
C <sub>12</sub>				
	chloro	SIH5840.25	heneicocyl-1,1,2	2-tetrahydrodecyltrichlorosilane
Fluorinate	d Alkyl-Silanes	- branched		
	_		h a u ta flu a u a 'a a u u	an an ann an altaich le an aile an
x 3 fluorinated carbons	chloro	SIH5842.0 SIH5842.2		opoxypropyltrichlorosilane opoxypropyltrimethoxysilane
	methoxy		<u> </u>	
x 4 fluorinated carbons	chloro	SIB1706.0		xyldimethylsiloxy)methyl-
			silylethyldimethy	
x 6 fluorinated carbons	chloro	SIT8176.3	tridecatluoro-2-(	tridecafluorohexyl)decyltrichlorosilane
DiAlkyl Sila	anec			
JIAINYI OIIC	ai i C3			
		2 Hydrolyzable Gro	•	
_	Next Carbon #	2 Hydrolyzable Gro Hydrolyzable Groups	Oups Product Code	Product Name
ighest Carbon # C <sub>2</sub>	Next Carbon #	Hydrolyzable Groups	Product Code	
_		Hydrolyzable Groups chloro	Product Code SID3402.0	diethyldichlorosilane
C <sub>2</sub>	${\tt G_2}$	Hydrolyzable Groups	Product Code	
_		Hydrolyzable Groups  chloro ethoxy	Product Code SID3402.0 SID3404.0	diethyldichlorosilane diethyldiethoxysilane
C <sub>2</sub>	${\tt G_2}$	chloro ethoxy	SID3402.0 SID3404.0 SID3537.0	diethyldichlorosilane diethyldiethoxysilane diisopropyldichlorosilane
C <sub>2</sub>	C <sub>2</sub>	Hydrolyzable Groups  chloro ethoxy	Product Code SID3402.0 SID3404.0	diethyldichlorosilane diethyldiethoxysilane
C <sub>2</sub>	${\tt G_2}$	chloro ethoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0	diethyldichlorosilane diethyldiethoxysilane diisopropyldichlorosilane diisopropyldimethoxysilane
C <sub>2</sub>	C <sub>2</sub>	chloro ethoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0	diethyldichlorosilane diethyldiethoxysilane diisopropyldichlorosilane diisopropyldimethoxysilane di-n-butyldichlorosilane
C <sub>2</sub>	C <sub>2</sub>	chloro ethoxy  chloro methoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0 SID3214.0	diethyldichlorosilane diethyldiethoxysilane diisopropyldichlorosilane diisopropyldimethoxysilane di-n-butyldichlorosilane di-n-butyldimethoxysilane
C <sub>2</sub>	C <sub>2</sub>	chloro ethoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0	diethyldichlorosilane diethyldiethoxysilane diisopropyldichlorosilane diisopropyldimethoxysilane di-n-butyldichlorosilane
C <sub>2</sub>	C <sub>2</sub>	chloro ethoxy  chloro methoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0 SID3214.0 SID3530.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	chloro ethoxy  chloro methoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0 SID3214.0 SID3530.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  chloro thloro methoxy  ethoxy methoxy ethoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0 SID3214.0 SID3530.0 SID3528.0	diethyldichlorosilane diethyldiethoxysilane diisopropyldichlorosilane diisopropyldimethoxysilane di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  chloro thloro methoxy  ethoxy methoxy ethoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0 SID3214.0 SID3530.0 SID3528.0 SID3528.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane dioputyldiethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>4</sub> C <sub>5</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>3</sub> C <sub>5</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  methoxy  methoxy  methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3203.0 SID3214.0 SID3530.0 SID3528.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane isobutylisopropyldimethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  methoxy  methoxy  chloro	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3538.0 SID3203.0 SID3530.0 SID3528.0 SII6452.6 SID3390.0 SID3391.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane disobutyldiethoxysilane diousobutyldiethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>4</sub> C <sub>5</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>3</sub> C <sub>5</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  methoxy ethoxy  chloro methoxy  chloro methoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3538.0 SID3203.0 SID3530.0 SID3528.0 SID3528.0 SID3390.0 SID3391.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane diobutyldiethoxysilane dicyclopentyldichlorosilane dicyclopentyldimethoxysilane  di-n-hexyldichlorosilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>4</sub> C <sub>5</sub> C <sub>6</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>3</sub> C <sub>5</sub> C <sub>6</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  methoxy  ethoxy  chloro methoxy  methoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3538.0 SID3203.0 SID3530.0 SID3528.0 SII6452.6 SID3390.0 SID3391.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane disobutyldiethoxysilane diousobutyldiethoxysilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>4</sub> C <sub>5</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>3</sub> C <sub>5</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  methoxy methoxy  chloro methoxy  chloro methoxy  chloro chloro chloro	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3538,0 SID3203.0 SID3530.0 SID3528.0 SID3528.0 SID3391.0 SID3391.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane dioputyldiethoxysilane  dicyclopentyldichlorosilane dicyclopentyldichlorosilane dicyclopentyldichlorosilane dicyclohexyldichlorosilane dicyclohexyldichlorosilane
C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>5</sub> C <sub>6</sub>	C <sub>2</sub> C <sub>3</sub> C <sub>4</sub> C <sub>3</sub> C <sub>5</sub> C <sub>6</sub>	chloro ethoxy  chloro methoxy  chloro methoxy  chloro methoxy  methoxy ethoxy  chloro methoxy  chloro methoxy  chloro methoxy	SID3402.0 SID3404.0 SID3537.0 SID3538,0 SID3538.0 SID3203.0 SID3530.0 SID3528.0 SID3528.0 SID3390.0 SID3391.0	diethyldichlorosilane diethyldiethoxysilane  diisopropyldichlorosilane diisopropyldimethoxysilane  di-n-butyldichlorosilane di-n-butyldimethoxysilane diisobutyldimethoxysilane diisobutyldiethoxysilane diobutyldiethoxysilane dicyclopentyldichlorosilane dicyclopentyldimethoxysilane  di-n-hexyldichlorosilane



	lyzable Groups		rolyzable Group
Product Code	Product Name	Product Code	Product Name
SIT8369.0 SIT8370.0	(3,3,3-trifluoropropyl)methyldichlorosilane (3,3,3-trifluoropropyl)methyldimethoxysilane	SIT8364.0	(3,3,3-trifluoropropyl)dimethylchlorosilane
	(-)-/	SIB1828.4	bis(trifluoropropyl)tetramethyldisilazane
SIN6597.5	nonafluorohexylmethyldichlorosilane	SIN6597.3	nonafluorohexyldimethylchlorosilane
		SIN6597.4	
SIT8172.0	(tridecafluoro-1,1,2,2-tetrahydrooctyl)methyldichlorosilane	SIT8170.0	(tridecafluoro-1,1,2,2-tetrahydrooctyl)dimethylchlorosilane
SH5840.6	(heptadecafluoro-1,1,2,2-tetrahydrodecyl)methyldichlorosilane	SIH5840.4	(heptadecafluoro-1,1,2,2-tetrahydrodecyl)dimethylchlorosilane

# Non-Functional Dipodal Silane Selection Guide

aliphatic			
	4 Hydrolyzeable Groups	5 Hydrolyzeable Groups	6 Hydrolyzeable Groups
Spacer atoms	Product Code/Name	Product Code/Name	Product Code/Name
1	SIB1635.0 bis(methyldimethoxysilyl)methane		SIB1821.0 bis(triethoxysilyl)methane
2	SIB1615.0 bis(methyldiethoxysilyl)ethane	SIT8185.8 1-(triethoxysilyl)-2- (diethoxymethylsilyl)ethane	SIB1817.0 bis(triethoxysilyI)ethane
2	SIB1632.0 bis(methyldimethoxysilyl)ethane		SIB1830.0 bis(trimethoxysilyl)ethane
2			SIB1829.0 1,2-bis(trimethoxysilyl)decane
6			SIB1832.0 1,6-bis(trimethoxysilyl)hexane
6			SIB1829.7 1,6-bis(trimethoxysilyl)-2,5-dimethylhexane
8			SIB1824.0 1,8-bis(triethoxysilyl)octane
8			SIB1832.7 1,8-bis(trimethoxysilyl)octan
aromatio	c/heteroatom		
romatic			SIB1831.0 bis(trimethoxysilylethyl)benzene
romatic			SIB1816.6 bis(triethoxysilyI)benzene
romatic			SIB1832.2 bis(trimethoxysilylmethyl)benzene
thylene oxide			SIB1824.84 bis(triethoxysilylpropyl)poly(ethyleneoxide)
iloxane			SIB1820.2 bis(triethoxysilylethyl)tetramethyldisiloxane
	(215) 547-1015	FAX: (215) 547-2484 ww	w.gelest.com

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# **Hydrophobic Silane Properties**

Conventional Surface Bonding

	name			MW	bp/mm (	mp)	<b>D</b> 4 <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
₽ сн₃	SIA0110.0 ACETOXYTRIMETHYLSILANE			132.23	103-4	(-32)	0.891	1.3890
CH₃Cosi −CH₃ CH₃	O-TRIMETHYLSILYL ACETATE $C_5H_{12}O_2Si$ Vapor pressure, 30°: 35 mm			Flashpoint: 4°C	C (39°F)			
	HYDROLYTIC SENSITIVITY: 4: n				05	400		01
	[2754-27-0] TSCA SIA0325.0	EC 220-404-2	HMIS: 3-4-1-X		25g	100g		2kg
CH2CH2SiCl3	ADAMANTYLETHYLTRICHLORO C <sub>12</sub> H <sub>19</sub> Cl <sub>3</sub> Si Contains app	roximately 25% α-		297.73 Flashpoint: 155	135 / 3 5°C (310°F)	(36-7)	1.2204	1.5135
出	Forms silica bonded phases in 1. Yang, S. S. and Gilpin, R. In HYDROLYTIC SENSITIVITY: 8: re	K. Anal. Chem. 19	<b>88,</b> <i>5</i> 9, 2750.	is				
	[37843-11-1] TSCA	EC 253-687-6	HMIS: 3-1-1-X		5g	25g		
ÇH₁ →CH₂Şi −CI	SIB0962.0  BENZYLDIMETHYLCHLOROSILA	NE		184.74	75-6 / 15		0.949	1.5040
ĆH <sub>y</sub>	C <sub>9</sub> H <sub>13</sub> CISi HYDROLYTIC SENSITIVITY: 8: re	eacts rapidly with mo	sture, water, protic solvent	Flashpoint: 73°	C (103°F)			
	[1833-31-4] TSCA		HMIS: 3-2-1-X		10g	50g		
Çı	SIB0970.0 BENZYLTRICHLOROSILANE			225.58	140-2 / 10		1.288	1.527
CH2Si-CI	C <sub>7</sub> H <sub>7</sub> Cl <sub>3</sub> Si			Flashpoint: 87°	C (189°F)		1.200	1.021
1763	Dipole moment: 1.78	nacte rapidly with re-	ieturo water profis seb		I rat, LD50: 2,830 r	ng/kg		
	HYDROLYTIC SENSITIVITY: 8: re [770-10-5] TSCA	eacts rapidly with mo EC 212-219-0	sture, water, protic solvent HMIS: 3-2-1-X	.5	25g	100g		
SC II	SIB0971.0					- 5		
OC3H4 OC3H4	BENZYLTRIETHOXYSILANE  C <sub>13</sub> H <sub>22</sub> O <sub>3</sub> Si	agata alawk with mai	nturaluator	254.40 Flashpoint: 127	148 / 26 7°C (261°F)		0.986	1.4628 <sup>25</sup>
	HYDROLYTIC SENSITIVITY: 7: re [2549-99-7] TSCA	EC 219-841-1	HMIS: 2-1-0-X		10g	50g		
Şi(CH₃)₂CI	SIB0994.0 2-(BICYCLOHEPTYL)DIMETHYLO C <sub>9</sub> H <sub>17</sub> CISi	CHLOROSILANE		188.77	52-5 / 1		0.99	
>	HYDROLYTIC SENSITIVITY: 8: re	eacts rapidly with mo	sture, water, protic solvent	Flashpoint: 87°	C (189°F)			
	[117046-42-1]		HMIS: 3-2-1-X		25g	100g		
SiCI	SIB0997.0 2-(BICYCLOHEPTYL)TRICHLORO	OSILANE		229.61	63-4 / 4.5		1.2678	1.4919
1>	C <sub>7</sub> H <sub>11</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: re	eacts rapidly with mo	sture, water, protic solvent	Flashpoint: 83°	C (181°F)			
V	[18245-29-9] TSCA SIB1068.0	EC 242-121-3	HMIS: 3-2-1-X		10g	50g		
,CH <sub>2</sub>	BIS(DIETHYLAMINO)DIMETHYLS	SILANE		202.42	192-5		0.826	1.435
SI CH <sub>3</sub>	C <sub>10</sub> H <sub>26</sub> N <sub>2</sub> Si Silylates diamines to cyclic di 1. Schwartz, E. et al. <i>J. Org.</i> ( See also SID4040.0	Chem. <b>1981,</b> 50, 5		Flashpoint: 35°	C (95°F)			
	HYDROLYTIC SENSITIVITY: 8: re [4669-59-4] TSCA	EC 225-116-0	HMIS: 3-3-1-X	.8	50g			
CH <sub>1</sub>	SIB1072.0 BIS(DIMETHYLAMINO)DIMETHY	I SII ANE		146.31	128-9	(-98)	0.810	1.4169 <sup>22</sup>
N CH <sub>3</sub>	C <sub>6</sub> H <sub>18</sub> N <sub>2</sub> Si Couples silanol terminated si See also SIB1185.0			Flashpoint: -3°		(-90)	0.010	1.4103
	HYDROLYTIC SENSITIVITY: 8: re [3768-58-9] TSCA	eacts rapidly with mo EC 223-200-1	sture, water, protic solvent HMIS: 3-4-1-X	is	25g	100g		
. EH1	SIB1706.0							
igui Paramarea	[BIS(NONAFLUOROHEXYLDIME' SILYLETHYLDIMETHYLCHLORO C <sub>21</sub> H <sub>33</sub> CIF <sub>18</sub> O <sub>2</sub> Si <sub>4</sub>		THYL]-	807.26	128 / 0.2		1.244 <sup>25</sup>	1.3705 <sup>25</sup>
T.	Forms self-cleaning surfaces							
(1)	HYDROLYTIC SENSITIVITY: 7: re	eacts slowly with moi	sture/water					

	name		MW	bp/mm (ı	mp)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$	
cu, cu, cu, cu,cu, ş—y—ş-cu,cu,cı	910.121.61.012		325.45 Flashpoint: 78	76-9 / 10 °C (172°F)		1.11	1.386	
CH <sub>3</sub> H CH <sub>3</sub>	Fluorinated blocking agent HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi  [39482-87-6] TSCA EC 254-470-9	sture/water HMIS: 2-2-1-X		50g				
(CH <sub>2</sub> ) <sub>2</sub> SiO Cl	SIB1837.0 BIS(TRIMETHYLSILOXY)DICHLOROSILANE 3,3-DICHLOROHEXAMETHYLTRISILOXANE		277.37	173	(-53)	1.0017	1.3983	
(CH <sub>3</sub> ),SiO CI	$\begin{array}{l} C_6 H_{18} Cl_2 O_2 Si_3 \\ Sterically \ hindered \ protecting \ group \ for \ diols \\ HYDROLYTIC \ SENSITIVITY: \ 8: \ reacts \ rapidly \ with \ mo \end{array}$		Vapor pressure					
	[2750-44-9]	HMIS: 3-2-1-X		25g				
(CH <sub>3</sub> ) <sub>3</sub> SiO Si CH <sub>3</sub>	SIB1843.0 BIS(TRIMETHYLSILOXY)METHYLMETHOXYSILAN METHOXYHEPTAMETHYLTRISILOXANE $C_8H_{24}O_3Si_3$	NE	252.53	82 / 47		0.862	1.3883 25	
	HYDROLYTIC SENSITIVITY: 1: no significant reaction	with aqueous systems HMIS: 3-2-1-X		25g				
	[7671-19-4] SIB1846.0	1 IIII 3. 0 2 · 1 - X		20y				
OSi(CH <sub>3</sub> ) <sub>2</sub> CH <sub>3</sub> C=NSi(CH <sub>3</sub> ) <sub>3</sub>	N,O-BIS(TRIMETHYLSILYL)ACETAMIDE BSA $C_8H_{21}NOSi_2$ Versatile blocking agent	: Vol. 21, p.62	203.43 Flashpoint: 42 TOXICITY: or	71-3 / 35 °C (108°F) ral rat, LD50: 1,580	(-24) mg/kg	0.832	1.418	
	F&F: Vol. 13, p 34; Vol. 16, p 285; Vol. 20, p 50 HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi							
	[10416-59-8] TSCA EC 233-892-7	HMIS: 3-2-1-X		25g	100g		2kg	
OSi(CH <sub>3</sub> ) <sub>3</sub> CF <sub>3</sub> C=NSi(CH <sub>3</sub> ) <sub>3</sub>	SIB1876.0 BIS(TRIMETHYLSILYL)TRIFLUOROACETAMIDE BSTFA C <sub>8</sub> H <sub>18</sub> F <sub>3</sub> NOSi <sub>2</sub>		257.40 Flashpoint: 24	45-50 / 15 °C (75°F)	(-10)	0.969	1.3840	
Cr3C-NanCr13f1	Silylation reagent for preparing derivatives of a 1. Stalling, D. et al. Biochem. Biophys., Res. C. HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo [25561-30-2] TSCA EC 247-103-9	omm. <b>1968,</b> 31, 616.	ts	25g	100g		2kg	
Fin Jen, och,	SIB1932.5  1-BUTYLDECAMETHYLPENTASILOXANYLETHYLTRIETHOXYSILANE Contains isomers	-	603.21	140-2 / 1		0.921	Lity	
Си, си, осущ	$\begin{split} &C_{22}H_{58}O_7Si_6\\ &Phase \ collapse \ resistant \ bonded \ phase\\ &HYDROLYTIC \ SENSITIVITY: 7: \ reacts \ slowly \ with \ moi\\ \end{split}$	sture/water HMIS: 2-2-1-X		10g				
250	SIB1934.0			v				
CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> S <sub>1</sub> =Ci CH <sub>3</sub>	n-BUTYLDIMETHYLCHLOROSILANE $C_6H_{15}\text{CISi}$ Forms bonded phases for HPLC		150.72 Flashpoint: 39	138 °C (102°F)		0.8751	1.4205	
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo [1000-50-6] TSCA	isture, water, protic solven HMIS: 3-2-1-X	ts	25g	100g			
	[1000-50-6] TSCA SIB1935.0	1 IIVIIO. 0-2-1-A		2Jy	1009			
CH <sub>3</sub> Me CH <sub>3</sub> Me	t-BUTYLDIMETHYLCHLOROSILANE $C_{\epsilon}H_{15}\text{CISi}$		Vapor pressur	124-6 °C (72°F) imperature: 405°C e, 100°: 476 mm	(87-90)	0.830		
	Silylation reagent - derivatives resistant to Grignards, alkyl lithium compounds, etc.  Blocking agent widely used in prostaglandin synthesis  F&F: Vol. 4, p 57, p 176; Vol. 5, p 74; Vol. 6, p 78; Vol. 8, p 58; Vol. 9, p 77; Vol. 10, p 62; Vol. 11, p 88; Vol. 12, p 83.  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solvents							
	[18162-48-6] TSCA EC 242-042-4	HMIS: 3-4-1-X	ıs	25g	100g		2kg	
СИ	SIB1937.0			· ·			J	
H <sub>3</sub> CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> S <sub>3</sub> -N(CH <sub>2</sub> ) <sub>2</sub> CH <sub>1</sub>	n-BUTYLDIMETHYL(DIMETHYLAMINO)SILANE  C <sub>8</sub> H <sub>21</sub> NSi  Highly reactive reagent for bonded phases with  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi		159.35 Flashpoint: 26	47-9 / 12 °C (79°F)		0.772	1.422	
	[181231-67-4] TSCA	HMIS: 3-3-1-X		10g	50g			
CH <sub>3</sub> CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub>	SIB1971.0 t-BUTYLISOPROPYLDIMETHOXYSILANE $C_9H_{22}O_2Si$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi		190.36	75 / 20		0.871	1.4189	

	name		MW	bp/mm (ı	np)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{\scriptscriptstyle 20}$
	SIB1972.0						
çı	n-BUTYLMETHYLDICHLOROSILANE		171.14	148		1.0424	1.4312
2CH2CH2-Si-CH3	C <sub>5</sub> H <sub>12</sub> Cl <sub>2</sub> Si		Flashpoint: 3	0°C (86°F)			
Ct	HYDROLYTIC SENSITIVITY: 8: reacts rapid [18147-23-4] TSCA EC 242-0		rents	10g			
	SIB1972.2	111110.0017		109			
CH2 CH2	t-BUTYLMETHYLDICHLOROSILANE		171.14	130-2	(88-90)		
c-c-si-ci	C <sub>5</sub> H <sub>12</sub> Cl <sub>2</sub> Si		Flashpoint: 2		(00-90)		
CH <sub>3</sub> CI	HYDROLYTIC SENSITIVITY: 8: reacts rapid	ly with moisture, water, protic solv		,			
	[18147-18-7] TSCA EC 242-	034-0 HMIS: 3-3-1-X		5g			
794	SIB1972.5						
CH-CH-SICI	p-(t-BUTYL)PHENETHYLDIMETHYLCHLO		254.87	122-3 / 2		0.95	
CII.		~5% meta isomer					
	HYDROLYTIC SENSITIVITY: 8: reacts rapid [93502-75-1]	ly with moisture, water, protic solv HMIS: 3-2-1-X	rents	25g			
	SIB1973.0	1 IIVIIO. 0-2-1-X		239			
	p-(t-BUTYL)PHENETHYLTRICHLOROSILA	NE	295.71	124-9 / 2.5		1.16	
CH2-CH2-SICI		β isomers	Flashpoint: 1			1.10	
70077.0	For bonded phase HPLC		componite 1	( )			
	HYDROLYTIC SENSITIVITY: 8: reacts rapid		rents				
	[211925-40-5]	HMIS: 3-2-1-X		25g			
	SIB1974.2						
	ω-BUTYLPOLY(DIMETHYLSILOXANYL)ET	THYL-	600-850			0.925	1.4124
· / CH <sub>2</sub> \ CH <sub>2</sub>	TRIETHOXYSILANE, tech-95 OC <sub>2</sub> H <sub>5</sub> 5-8 Me <sub>2</sub> S	SiO groups, contains isomers					
-O Si -O Si -CH <sub>2</sub> CF	2-Si—OC <sub>2</sub> H <sub>5</sub>	oro groups, contains isomers					
<sub>3</sub> \ CH <sub>3</sub> /3-6 CH <sub>3</sub>	OC <sub>2</sub> H <sub>5</sub>						
	HYDROLYTIC SENSITIVITY: 7: reacts slowl						
		HMIS: 2-2-1-X		25g			
	SIB1982.0						
ner one our order	n-BUTYLTRICHLOROSILANE		191.56	142-3		1.1608	1.4364
CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> SiCl <sub>3</sub>	C <sub>4</sub> H <sub>9</sub> Cl <sub>3</sub> Si Vapor pressure, 31°: 10 mm		Flashpoint: 4	5°C (113°F)			
	HYDROLYTIC SENSITIVITY: 8: reacts rapid	ly with moisture, water, protic solv	vents				
	[7521-80-4] TSCA EC 231-3			25g	100g		
	SIB1985.0						
CH3 CI	t-BUTYLTRICHLOROSILANE		191.56	142-3	(97-100)	1.1608	1.436
,c-c-si-c1	C <sub>4</sub> H <sub>9</sub> Cl <sub>3</sub> Si		Flashpoint: 4	0°C (104°F)			
CH <sub>3</sub> Cl	Forms silanetriol HYDROLYTIC SENSITIVITY: 8: reacts rapid	ly with maisture, water proticeals	vonte				
	[18171-74-9] TSCA EC 242-0		rents	10g	50g		
	SIB1986.0				9		
H <sub>2</sub> ) <sub>3</sub> Si(OCH <sub>2</sub> CH <sub>3</sub> ) <sub>3</sub>	n-BUTYLTRIETHOXYSILANE		220.38	192-3		0.8883	1.4011
	C <sub>10</sub> H <sub>24</sub> O <sub>3</sub> Si			.02 0			
	HYDROLYTIC SENSITIVITY: 7: reacts slowl	•					
	[4781-99-1]	HMIS: 2-2-1-X		25g			
	SIB1988.0						
L2CH2CH2Si(OCH3)3	n-BUTYLTRIMETHOXYSILANE		178.30	164-5		0.9312	1.3979
	C <sub>7</sub> H <sub>18</sub> O <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowl	v with moisture/water	Flashpoint: 4	9°C (120°F)			
	[1067-57-8] TSCA EC 213-9			25g	100g		
QCH <sub>2</sub>	SIB1989.0			, , ,			
-c-si-och	t-BUTYLTRIMETHOXYSILANE		178.30	140-1		0.903	1.3941
Is OCH	$C_7H_{18}O_3Si$						
><	HYDROLYTIC SENSITIVITY: 7: reacts slowl			40			
53	[18395-29-4]	HMIS: 3-2-1-X		10g			
52	SIC2266.0						
( )	13-(CHLORODIMETHYLSILYLMETHYL)HE	EPTA-	487.37	200-10 / 0.01		0.848 25	1.4542 <sup>30</sup>
	COSANE, 95% C <sub>30</sub> H <sub>63</sub> CISi						
	Forms hydrophobic honded phases						
11/4 - 11 - 12	HYDROLYTIC SENSITIVITY: 8: reacts rapid	ly with moisture, water, protic solv	vents				
	[194243-00-0] TSCA	HMIS: 3-1-1-X		10g			

	name		MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	$n_D^{20}$
	SIC2266.5						
5	11-(CHLORODIMETHYLSILYL)METHYLTRI	COSANE	431.27	170 / 0.075		0.887	1.4575 22
53		contains ~5% isomers					
5.2	Forms self-assembled oleophilic monol	ayers					
3	Employed as bonded phase in HPLC						
(>	See also SID4401.0						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly	with moisture/water					
		HMIS: 3-1-1-X		10g			
0	SIC2465.0						
4	CYCLOHEXYLDIMETHYLCHLOROSILANE		176.76	52-3 / 2		0.956	1.4626
1	C <sub>8</sub> H <sub>17</sub> CISi		Flashpoint: 63	3°C (145°F)			
CH	Silane blocking agent with good resista						
LC CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly		ents	05	400-		
	[71864-47-6]	HMIS: 3-2-1-X		25g	100g		
v .	SIC2468.0		107.10	/ /-		4.005	4 4704
1	CYCLOHEXYLMETHYLDICHLOROSILANE		197.18	83 / 15		1.095	1.4724
Si Ci	C <sub>7</sub> H <sub>14</sub> Cl <sub>2</sub> Si	with mainture, water preting solve	Flashpoint: 66	6°C (151°F)			
C CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly [5578-42-7] TSCA EC 226-9:		ints	25g	2kg		
	[00.0.12.1]	JO O TIIVIIO. J-Z-1-A		20g	ZNY		
	SIC2469.0	_	400.04	400		0.0470	4.4054
10200	CYCLOHEXYLMETHYLDIMETHOXYSILAN C <sub>9</sub> H <sub>20</sub> O <sub>2</sub> Si	E	188.34	196 °°C (151°E)		0.9472	1.4354
Si OCII,	Vapor pressure, 20°: 12 mm		Flashpoint: 66	ral rat, LD50: 3,000mg/kg			
C OCH,	Donor for polyolefin polymerization		TOMOTTI. U	rai rat, LD00. 3,000mg/kg			
	HYDROLYTIC SENSITIVITY: 7: reacts slowly	with moisture/water					
	[17865-32-6] TSCA	HMIS: 2-2-1-X		25g	100g		2kg
	SIC2470.0			_			
	(CYCLOHEXYLMETHYL)TRICHLOROSILAI	NE	231.62	94-8 / 11			
1	C <sub>7</sub> H <sub>13</sub> Cl <sub>3</sub> Si		· ·-				
CH <sub>2</sub> SICL	HYDROLYTIC SENSITIVITY: 8: reacts rapidly	with moisture, water, protic solve	ents				
Sicil	[18388-16-4] TSCA EC 242-2			10g			
	SIC2480.0						
	CYCLOHEXYLTRICHLOROSILANE		217.60	90-1 / 10		1.222	1.4774
	$C_6H_{11}CI_3Si$		Flashpoint: 9	1°C (196°F)			
1	Intermediate for melt-processable silses	squioxane-siloxanes.1					
A'cı	Employed in solid-phase extraction colu						
ci ci	1. Lichtenhan, J. et al. Macromolecules	<b>1993,</b> <i>2</i> 6, 2141.					
	<ol><li>Tippins, B. Nature 1988, 334, 273.</li></ol>						
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly		ents	250	100a		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6		ents	25g	100g		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0				100g		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE		204.34	25g 207-9	100g		
Д, осн,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6:  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si	39-2 HMIS: 3-2-1-X			100g		
OCII,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly	39-2 HMIS: 3-2-1-X with moisture/water		207-9			
ocii,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]	39-2 HMIS: 3-2-1-X			100g 50g		
OCH,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0	39-2 HMIS: 3-2-1-X with moisture/water	204.34	207-9 10g		1.40	
ocu,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>3</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%	39-2 HMIS: 3-2-1-X with moisture/water		207-9		1.19	
ocu,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X	204.34	207-9 10g		1.19	
ocu, ocu, sicl,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X	204.34	207-9 10g 85-9 / 1.25	50g	1.19	
ocii,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X	204.34	207-9 10g		1.19	
ocit, ocit, sicl,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>9</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X	204.34 245.65 ints	207-9 10g 85-9 / 1.25	50g		1,4713
ocit, ocit, sicl,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X	204.34 245.65 ints	207-9 10g 85-9 / 1.25 10g 178-9	50g	1.19	1.4713
o ocu,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>9</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X	204.34 245.65 ents 203.57 Flashpoint: 77	207-9 10g 85-9 / 1.25 10g 178-9	50g		1.4713
o ocu,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>9</sub> Cl <sub>3</sub> Si	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X	204.34 245.65 ents 203.57 Flashpoint: 77	207-9 10g 85-9 / 1.25 10g 178-9	50g		1.4713
o ocu,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>9</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4]  TSCA EC 238-6	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X	204.34 245.65 ents 203.57 Flashpoint: 77	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)	50g		1.4713
SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> C <sub>15</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>8</sub> H <sub>9</sub> C <sub>13</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X	204.34  245.65  ints  203.57  Flashpoint: 75	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g	50g	1.225	
o ocu,	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOPENTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>9</sub> H <sub>9</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE	39-2 HMIS: 3-2-1-X with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X	204.34  245.65  ints  203.57 Flashpoint: 73  190.31	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g	50g		1.4713 1.4240 <sup>25</sup>
SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> C <sub>15</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>8</sub> H <sub>9</sub> C <sub>13</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0	with moisture/water HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X	204.34  245.65  ints  203.57  Flashpoint: 75	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g	50g	1.225	
SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>3</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>3</sub> H <sub>9</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>18</sub> O <sub>3</sub> Si	with moisture/water HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X	204.34  245.65  ints  203.57 Flashpoint: 73  190.31	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g	50g	1.225	
SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>3</sub> H <sub>3</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>18</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]	with moisture/water HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve 21-6 HMIS: 3-2-1-X	204.34  245.65  ints  203.57 Flashpoint: 73  190.31	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)	50g 50g	1.225	
SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>3</sub> H <sub>3</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>18</sub> O <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0	with moisture/water HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve 21-6 HMIS: 3-2-1-X	204.34  245.65  Ints  203.57  Flashpoint: 75  190.31  Flashpoint: 54	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g	50g 50g	1.225 0.990 <sup>25</sup>	1.4240 <sup>25</sup>
SiCl <sub>3</sub> -Si(OCH <sub>3</sub> ) <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>8</sub> H <sub>3</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>18</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0  n-DECYLDIMETHYLCHLOROSILANE	with moisture/water HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve 21-6 HMIS: 3-2-1-X	204.34  245.65  Ints  203.57  Flashpoint: 75  190.31  Flashpoint: 54	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2	50g 50g	1.225	
SiCl <sub>3</sub> SiCl <sub>3</sub> SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>3</sub> H <sub>3</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>18</sub> O <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0	with moisture/water HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve 11-6 HMIS: 3-2-1-X	204.34  245.65  ints  203.57 Flashpoint: 75  190.31 Flashpoint: 54	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2	50g 50g	1.225 0.990 <sup>25</sup>	1.4240 <sup>25</sup>
SiCl <sub>3</sub> SiCl <sub>3</sub> SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>2</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>18</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0  n-DECYLDIMETHYLCHLOROSILANE  C <sub>12</sub> H <sub>27</sub> CISi	39-2 HMIS: 3-2-1-X  with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X  y with moisture, water, protic solve 21-6 HMIS: 3-2-1-X  with moisture/water HMIS: 3-2-1-X	204.34  245.65  ints  203.57 Flashpoint: 75  190.31 Flashpoint: 54	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2	50g 50g	1.225 0.990 <sup>25</sup>	1.4240 <sup>25</sup>
SiCl <sub>3</sub> SiCl <sub>3</sub> SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>3</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>9</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>6</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>16</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0  n-DECYLDIMETHYLCHLOROSILANE  C <sub>12</sub> H <sub>27</sub> CISi  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [38051-57-9] TSCA EC 253-7	39-2 HMIS: 3-2-1-X  with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X  y with moisture, water, protic solve 21-6 HMIS: 3-2-1-X  with moisture/water HMIS: 3-2-1-X	204.34  245.65  ints  203.57 Flashpoint: 75  190.31 Flashpoint: 54	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2  37°C (279°F)	50g 50g 100g	1.225 0.990 <sup>25</sup>	1.4240 <sup>25</sup>
SiCl <sub>3</sub> SiCl <sub>3</sub> SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>9</sub> H <sub>15</sub> Cl <sub>9</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>6</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>16</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0  n-DECYLDIMETHYLCHLOROSILANE  C <sub>12</sub> H <sub>27</sub> CISi  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [38051-57-9] TSCA EC 253-7  SID2662.0	39-2 HMIS: 3-2-1-X  with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X  y with moisture, water, protic solve 21-6 HMIS: 3-2-1-X  with moisture/water HMIS: 3-2-1-X	204.34  245.65  Ints  203.57  Flashpoint: 77  Flashpoint: 75  234.88  Flashpoint: 13  ints	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2  37°C (279°F)  25g	50g 50g 100g	1.225 0.990 <sup>25</sup> 0.866	1.4240 <sup>25</sup>
SiCl <sub>3</sub> SiCl <sub>3</sub> SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>3</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>9</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>6</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>16</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0  n-DECYLDIMETHYLCHLOROSILANE  C <sub>12</sub> H <sub>27</sub> CISi  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [38051-57-9] TSCA EC 253-7	39-2 HMIS: 3-2-1-X  with moisture/water HMIS: 2-3-1-X  y with moisture, water, protic solve HMIS: 3-2-1-X  y with moisture, water, protic solve 21-6 HMIS: 3-2-1-X  with moisture/water HMIS: 3-2-1-X	204.34  245.65  Inits  203.57  Flashpoint: 75  190.31  Flashpoint: 54  234.88  Flashpoint: 13  ints	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2  37°C (279°F)  25g	50g 50g 100g	1.225 0.990 <sup>25</sup>	1.4240 <sup>25</sup>
SiCl <sub>3</sub> SiCl <sub>3</sub> SiCl <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [98-12-4] TSCA EC 202-6  SIC2482.0  CYCLOHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [17865-54-2]  SIC2490.0  CYCLOOCTYLTRICHLOROSILANE, 95%  C <sub>8</sub> H <sub>15</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [18290-59-0]  SIC2555.0  CYCLOPENTYLTRICHLOROSILANE  C <sub>5</sub> H <sub>9</sub> Cl <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [14579-03-4] TSCA EC 238-6  SIC2557.0  CYCLOPENTYLTRIMETHOXYSILANE  C <sub>8</sub> H <sub>16</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly  [143487-47-2]  SID2660.0  n-DECYLDIMETHYLCHLOROSILANE  C <sub>12</sub> H <sub>27</sub> CISi  HYDROLYTIC SENSITIVITY: 8: reacts rapidly  [38051-57-9] TSCA EC 253-70  SID2662.0  n-DECYLMETHYLDICHLOROSILANE	39-2 HMIS: 3-2-1-X  with moisture/water HMIS: 2-3-1-X  with moisture, water, protic solve HMIS: 3-2-1-X  with moisture, water, protic solve 21-6 HMIS: 3-2-1-X  with moisture/water HMIS: 3-2-1-X  with moisture/water HMIS: 3-1-1-X	204.34  245.65  ints  203.57 Flashpoint: 73  190.31 Flashpoint: 54  234.88 Flashpoint: 13  ints  255.31 Flashpoint: 12	207-9  10g  85-9 / 1.25  10g  178-9  7°C (171°F)  25g  75 / 10  4°C (129°F)  10g  98 / 2  37°C (279°F)  25g	50g 50g 100g	1.225 0.990 <sup>25</sup> 0.866	1.4240 <sup>25</sup>

	name		MW	bp/mm (ı	mp)	D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
Cl	SID2663.0						
CH4CH <sub>20</sub> —Si—Cl	n-DECYLTRICHLOROSILANE		275.72	133-7 / 5		1.0540	1.4528
en en	C <sub>10</sub> H <sub>21</sub> Cl <sub>3</sub> Si			110°C (>230°F)			
CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [13829-21-5] TSCA EC 237-540-3	sture, water, protic solvents HMIS: 3-1-1-X	3	25g	1000	1	
V2.3-W	SID2665.0	TIMIO. O T TX			1008	,	
OC <sub>2</sub> H <sub>5</sub>	n-DECYLTRIETHOXYSILANE		304.54	150 / 8		0.8790	1.4220
H <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> — Si — OC <sub>2</sub> H <sub>2</sub>	C <sub>16</sub> H <sub>36</sub> O <sub>3</sub> Si		001.01	100 / 0		0.0700	1.1220
OC <sub>2</sub> H <sub>4</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ture/water					
	[2943-73-9] EC 220-940-7	HMIS: 2-1-0-X		25g	100ე	1	
Section 1	SID3203.0						
nC <sub>4</sub> H <sub>9</sub> Cl	DI-n-BUTYLDICHLOROSILANE		213.22	212		0.991	1.4448
nC <sub>4</sub> H <sub>9</sub> Cl	C <sub>8</sub> H <sub>18</sub> Cl <sub>2</sub> Si	atura uratar mustis salusanti	Flashpoint: 64	F°C (147°F)			
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [3449-28-3] TSCA	HMIS: 3-2-1-X	5	10g	500	1	
	SID3214.0				005	,	
nC <sub>3</sub> H <sub>9</sub> , OCH <sub>3</sub>	DI-n-BUTYLDIMETHOXYSILANE		204.39	125 / 50		0.861	
nC4Ho OCH	C <sub>10</sub> H <sub>24</sub> O <sub>2</sub> Si		Flashpoint: 10				
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist		•				
	[18132-63-3] TSCA	HMIS: 3-1-1-X		25g			
си, и си	SID3349.0					_	
$I_{ij}$ - $\hat{N}$	1,3-DI-n-BUTYLTETRAMETHYLDISILAZANE		245.55	81 / 2		0.80	1.4353
сн <sub>3</sub> сн <sub>3</sub>	C <sub>12</sub> H <sub>31</sub> NSi <sub>2</sub> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ture/water	Flashpoint: 86	)*U (18/°F)			
	[82356-80-7]	HMIS: 2-2-1-X		25g	1000	1	
	SID3360.0				. 505	•	
THE PERSON NAMED IN	1,5-DICHLOROHEXAMETHYLTRISILOXANE, tech-9	95	277.37	184	(-53)	1.018	1.4071
сн, сн, сн,	C <sub>6</sub> H <sub>18</sub> Cl <sub>2</sub> O <sub>2</sub> Si <sub>3</sub>		Flashpoint: 76		( 00)		
şi-o-şi-o-şi-cl	ΔHvap: 11.4 kcal/mole		•				
си, си, си,	Vapor pressure, 50°: 1 mm						
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [3582-71-6] TSCA EC 222-707-5	sture, water, protic solvents HMIS: 3-2-1-X	š	25g	1000		
		TIIVIIO. 3-2-1-X		23g	1000	<b>)</b>	
	SID3367.6 DICHLOROPHENYLTRICHLOROSILANE, 95%		280.44	260-1		1.553	1.564
CIX	$C_6H_3CI_5Si$ Isomeric mixture		Flashpoint: 15			1.000	1.004
	Vapor pressure, 102°: 7 mm			,			
CI	Monomer for high refractive index resins						
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois		3	05			
	[27137-85-5] TSCA EC 248-254-3	HMIS: 3-1-1-X		25g			
0200110 200110	SID3372.0		000.00			4 000	4.4054
сн3 сн3	1,3-DICHLOROTETRAMETHYLDISILOXANE C <sub>4</sub> H <sub>12</sub> Cl <sub>2</sub> OSi <sub>2</sub>		203.22 Flashpoint: 15	138 5°C (50°F)	(-37)	1.039	1.4054
ci—și-o—și-ci	Vapor pressure, 25°: 8 mm		ι ιαδιτμυπτί. 10	, 0 (39 1 )			
CH <sub>3</sub> CH <sub>3</sub>	Diol protection reagent						
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois		3				
	[2401-73-2] TSCA EC 219-278-1	HMIS: 3-4-1-X		25g	100g		2kg
	SID3382.0						
	DICYCLOHEXYLDICHLOROSILANE		265.30	123 / 0.4		1.103	
Set	C <sub>12</sub> H <sub>22</sub> CI <sub>2</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois	sture water protice solvents	Flashpoint: 14	19°C (300°F)			
1	[18035-74-0]	HMIS: 3-1-1-X	,	25g			
	SID3390.0						
	DICYCLOPENTYLDICHLOROSILANE		237.24	105-7 / 10		1.110	
$c_1-s_1-c_1$	C <sub>10</sub> H <sub>18</sub> Cl <sub>2</sub> Si		Flashpoint: 84			• =	
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois		ŝ	•			
	[139147-73-2]	HMIS: 3-2-1-X		10g	50ც	]	
	SID3391.0						
	DICYCLOPENTYLDIMETHOXYSILANE		228.40	120 / 6		1.000	1.466
H,CO-SI-OCH,	C <sub>12</sub> H <sub>24</sub> O <sub>2</sub> Si		Flashpoint: 10	)2°C (216°F)			
1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	Employed in propylene polymerization HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ture/water					
	THE ROLL TO SENSITIVITY. 1. TEACLS SIDWIY WILL MOIS			10g	500	1	
	[126990-35-0] TSCA	ПIVIIО. 3-1-1-A			506	,	
	[126990-35-0] TSCA SID3394 0	HMIS: 3-1-1-X					
cu cu cu	SID3394.0	ПІЙІЗ. 3-1-1-А	296.59			0.912	1.389
CHI CHI CHI		HIVIIO. 3-1-1-A	296.59	51-2 / 0.8		0.912	1.389
cur cur cur	SID3394.0 1,5-DIETHOXYHEXAMETHYLTRISILOXANE		296.59			0.912	1.389

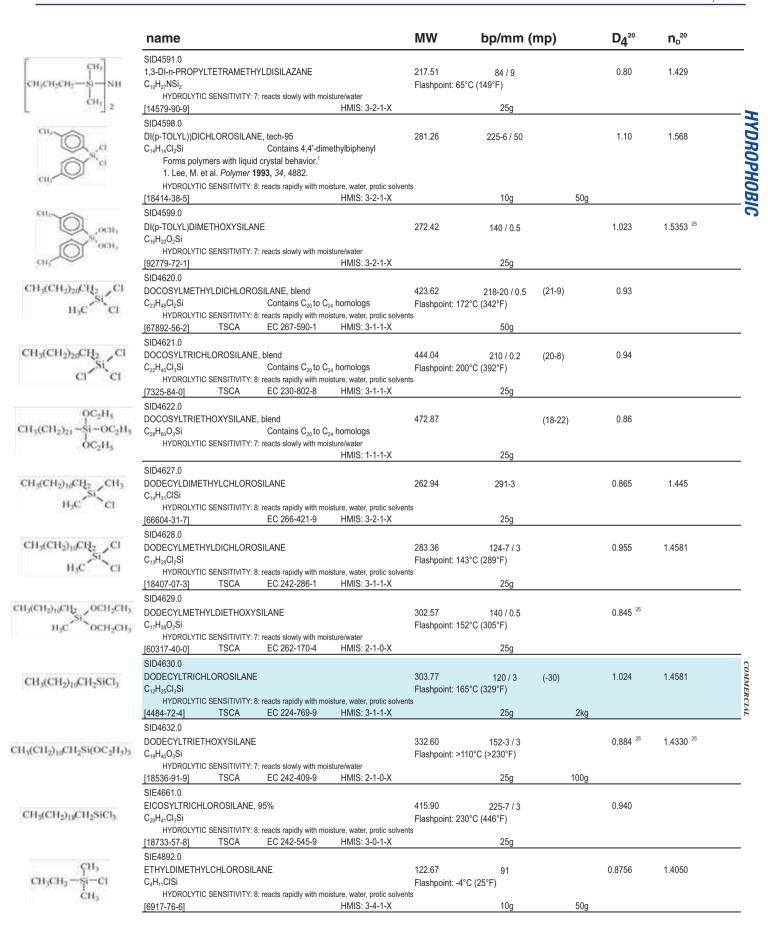
	name		MW	bp/mm (m	p)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$	
H <sub>3</sub> CH <sub>2</sub> NSi(CH <sub>3</sub> ) <sub>3</sub>	SID3398.0 (DIETHYLAMINO)TRIMETHYLSILANE TMSDEA $C_7H_70$ NSi		145.32 Flashpoint: 10 ΔHform: -87.	°C (50°F)	(-10)	0.7627	1.4109	
H <sub>3</sub> CH <sub>2</sub>	Silylation reagent F&F: Vol. 3, p 317; Vol. 4, p 544; Vol. 6, p 634; V HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ure/water		25-	400-		21	
	[996-50-9] TSCA EC 213-637-6 SID3402.0	HMIS: 3-4-1-X		25g	100g		2kg	
CH <sub>3</sub> CH <sub>2</sub> , CI	DIETHYLDICHLOROSILANE $C_4H_{10}Cl_2Si$ Thermal conductivity: 0.134 W/m $^{\circ}C$		157.11 Flashpoint: 27 TOXICITY: or		(-96.5) /kg	1.0504	1.4309	
CH₃CH₂′ CI	Dipole moment: 2.4  Surface tension: 30.3 mN/m  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois	ture, water, protic solver	Vapor pressur ΔHvap: 10.0 nts					
	[1719-53-5] TSCA EC 217-005-0	HMIS: 3-3-1-X		25g	100g			
H <sub>3</sub> CH <sub>2</sub> OC <sub>2</sub> H <sub>5</sub>	SID3404.0 DIETHYLDIETHOXYSILANE $C_8H_{20}O_2Si$ Vapor pressure, 73°: 100 mm		176.33 Flashpoint: 43	157 °C (109°F)		0.8622	1.4022	
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist [5021-93-2] TSCA EC 225-706-8	ure/water HMIS: 2-2-1-X		10g	50g			
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>5</sub> CI	SID3510.0 DI-n-HEXYLDICHLOROSILANE C <sub>17</sub> H <sub>26</sub> Cl <sub>2</sub> Si		269.33 Flashpoint: 88	111-3 / 6		0.962	1.4518	
H <sub>3</sub> (CH <sub>2</sub> ) <sub>5</sub> CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois			, ,	50			
H <sub>0</sub> C <sub>s</sub> CH <sub>5</sub> CH <sub>6</sub>	[18204-93-8] TSCA EC 242-093-2 SID3526.0 DIISOBUTYLCHLOROSILANE	HMIS: 3-2-1-X	178.78	10g	50g	0.995	1.4340	
CH <sub>3</sub>	C <sub>8</sub> H <sub>19</sub> ClSi HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois		Flashpoint: 42 nts	, ,				
His CH	[18279-73-7] SID3528.0	HMIS: 3-2-1-X		25g				
(H) <sub>E</sub> 1—4—DCH <sub>2</sub> CH <sub>3</sub> (M)	DIISOBUTYLDIETHOXYSILANE  C <sub>12</sub> H <sub>28</sub> O <sub>2</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ure/water	232.44	221		0.845	1.418	
en,	[18297-14-8]	HMIS: 2-2-1-X		10g				
11,C, C11, C11, C11, C11, C11, C11, C11,	$\begin{split} &\text{SID3530.0} \\ &\text{DIISOBUTYLDIMETHOXYSILANE} \\ &C_{10}H_{24}O_2Si \\ &\text{Intermediate for diisobutyIsilanediol, a liquid crys} \\ &\text{Employed in polyolefin polymerization} \end{split}$	tal	204.39 Flashpoint: 10	120 / 6 2°C (216°F)		0.87	1.4167	
нести	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist  [17980-32-4] TSCA	ure/water HMIS: 2-1-1-X		10g	50g			
н <sub>1</sub> с сн	SID3537.0 DIISOPROPYLDICHLOROSILANE C <sub>e</sub> H <sub>14</sub> Cl <sub>2</sub> Si		185.17 Flashpoint: 43	64-5 / 25 °C (109°F)		1.026	1.4450	
CI-SI-CI H <sub>3</sub> C CH <sub>3</sub>	Forms bis(blocked) or tethered alcohols <sup>1,2</sup> Used as tether in ring-closing-metathesis (RCM) 1. Bradford, C. et al. <i>Tetrahedron Lett.</i> <b>1995</b> , <i>36</i> , 2. Hutchinson, J. et al. <i>Tetrahedron Lett.</i> <b>1991</b> , <i>3</i> 3. Evans, P. A. et al. <i>J. Am. Chem. Soc.</i> <b>2003</b> , <i>1</i> :	4189. 2, 573. 25, 14702.						
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [7751-38-4]	HMIS: 3-2-1-X	its	10g	50g		2kg	
n <sub>i</sub> c cu,	SID3538.0 DIISOPROPYLDIMETHOXYSILANE $C_8H_{20}O_2Si$		176.33 Flashpoint: 43	85-7 / 50 °C (109°F)		0.875	1.4140	
H³C CH² CH²	Cocatalyst for α-olefin polymerization. <sup>1</sup> 1. Lee, S. et al. U.S. Patent 5,223,466, 1993. HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ure/water						
	[18230-61-0] TSCA SID3544.0	HMIS: 3-2-1-X		10g	50g		2kg	
-seoculentil	3,5-DIMETHOXYPHENYLTRIETHOXYSILANE  C <sub>14</sub> H <sub>24</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	uraluator	300.43	136-8 / 0.6		1.050		
	HYDROLYTIC SENSITIVITY: /: reacts slowly with moist	HIP WATER						

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	name		MW	bp/mm (mp)		D4 <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>	
	SID3605.0 (N,N-DIMETHYLAMINO)TRIMETHYLSILANE TMSDMA, PENTAMETHYLSILANAMINE		117.27 Flashpoint: -19°C (			0.741	1.3970	
CH <sub>3</sub> N—Si—CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	C <sub>5</sub> H <sub>15</sub> NSi Selectively silylates equatorial hydroxyl groups in Stronger silylation reagent than HMDS; silylates Dialkylaminotrimethylsilanes are used in the syn 1. Yankee, E. et al. <i>J. Am. Chem. Soc.</i> <b>1972</b> , 94, 2. Rühlman, K. <i>Chem. Ber.</i> <b>1961</b> , 94, 1876. 3. Kořínek, M. et al. <i>Synthesis</i> <b>2009</b> , 1291. HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	amino acids. <sup>2</sup> thesis of pentamethini , 3651.		ole				
	[2083-91-2] TSCA EC 218-222-3 SID4040.0	HMIS: 3-4-1-X		25g	100g		2kg	
CH <sub>2</sub> CHCH <sub>2</sub> CH <sub>3</sub> H <sub>3</sub> C NII  CH <sub>3</sub> CHCH <sub>2</sub> CH <sub>3</sub>	DIMETHYLBIS(s-BUTYLAMINO)SILANE, 95%  C <sub>10</sub> H <sub>22</sub> N <sub>2</sub> Si  Vapor pressure, 20°: 3 mm  Chain extender for silicones  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois  [93777-98-1] TSCA EC 298-130-8	ture, water, protic solvent HMIS: 3-3-1-X	202.42 Flashpoint: 40°C (1 TOXICITY: oral rat Autoignition tempe	, LD50: 907 mg/kg	100g	0.810	1.4271	
ÇH <sub>3</sub> ÇH <sub>3</sub> CH <sub>3</sub> ÇCH <sub>2</sub> CH <sub>2</sub> S; – С) CH <sub>3</sub> CH <sub>3</sub>	SID4065.0 (3,3-DIMETHYLBUTYL)DIMETHYLCHLOROSILANE NEOHEXYLDIMETHYLCHLOROSILANE C <sub>e</sub> H <sub>19</sub> CISi Blocking agent		178.78 Flashpoint: 38°C (1	167 100°F)		0.849	1.4240	
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [96220-76-7] TSCA-L	ture, water, protic solvent HMIS: 3-3-1-X	S	25g	100g			
(CH <sub>3</sub> ) <sub>3</sub> C CH <sub>2</sub> CH <sub>2</sub> - S - CI	SID4069.0 (3,3-DIMETHYLBUTYL)TRICHLOROSILANE NEOHEXYLTRICHLOROSILANE $C_6H_{13}Cl_3Si$		219.61	183-4		1.1355	1.4479	
Ci	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [105732-02-3] SID4074.0	ture, water, protic solvent HMIS: 3-3-1-X		25g				
CH <sub>2</sub> -Si-Cl	(DIMETHYLCHLOROSILYL)METHYLPINANE  C <sub>12</sub> H <sub>23</sub> ClSi  1*S,2*S,5*S [α] <sub>0</sub> : -5.15; >95% (  Acetylenic derivative forms chiral polymer memb  1. Aoki, T. et al. <i>Makromol. Chem., Rapid Comm</i>	orane that resolves am un. <b>1992</b> , <i>13</i> , 565.		93-4 / 2 198°F)		0.957	1.478	
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois  [2182-66-3] TSCA EC 218-562-2	ture, water, protic solvent HMIS: 3-2-1-X	S	10g				
CH <sub>3</sub>	SID4074.4  1,1-DIMETHYLCYCLOSILAZANES, 22-25% in hexan Primarily trimer and tetramer Hydrophobic surface treatment for silica HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist TSCA		Flashpoint: 20°C (-	25°F) 100g	1.5kg	0.69		
СH <sub>3</sub> CO-Şi-ОССH <sub>3</sub>	SID4076.0  DIMETHYLDIACETOXYSILANE  C <sub>6</sub> H <sub>12</sub> O <sub>4</sub> Si  Reagent for the preparation of cis-diols and corti  1. Kelley, R. J. <i>Chromatogr.</i> <b>1969</b> , <i>43</i> , 229.		176.24 Flashpoint: 37°C (§	164-6	o.g	1.054	1.4030	
	F&F: Vol. 3, p. 113.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist  [2182-66-3] TSCA EC 218-562-2	ture/water HMIS: 2-3-1-X		100g	500g			
N235	DIMETHYLDICHLOROSILANE  C <sub>2</sub> H <sub>6</sub> Cl <sub>2</sub> Si  Viscosity: 0.47 cSt  Surface tension: 20.1 mN/m		129.06 Flashpoint: -10°C ( TOXICITY: ihl rat, Autoignition tempe	70-1 (-76)  14°F) LC50: 930 ppm/4H		1.0637	1.4055	
CH <sub>3</sub> Cl−Si−Cl CH <sub>3</sub>	ΔHvap: 8.0 kcal/mole ΔHcomb: -491 kcal/mole Vapor pressure, 17°: 100 mm Coefficient of thermal expansion: 1.3 x 10 <sup>-3</sup> AIR TRANSPORT FORBIDDEN		Flammability limit: Critical temperature Critical pressure: 3 Specific heat: 0.22	e: 247.2° 34.4 atm				
	Fundamental monomer for silicones Employed in the tethering of two olefins for the c 1. Van de Weghe, P. et al. <i>Org. Lett.</i> <b>2002</b> , <i>4</i> , 41 F&F: Vol. 3, p 114; Vol. 4, p 183.	05.		nesis of Attenol A.1				
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois  [75-78-5] TSCA EC 200-901-0	ture, water, protic solvents HMIS: 3-4-2-X		500g S-019 container required -	2kg not included		18kg	

	name			MW	bp/mm (	mp)	$D_4^{20}$	$n_{\scriptscriptstyle D}^{^{20}}$	
	SID4120.1								
ÇH <sub>3</sub>	DIMETHYLDICHLOROSILANE,	99+%		129.06	70-1	(-76)	1.0637	1.4055	
CI-Si-CI	C <sub>2</sub> H <sub>6</sub> Cl <sub>2</sub> Si			Flashpoint: -1	0°C (14°F)				
CH <sub>3</sub>	Redistilled  AIR TRANSPORT FORBIE	DEN							
	HYDROLYTIC SENSITIVITY: 8:		ture water protic solvent	ę.					
	[75-78-5] TSCA	EC 200-901-0	HMIS: 3-4-2-X	3	25g	500g		18kg	
	[]			* zDR-S-019 or	zCYL-S-019 containe	_	uded		
	SID4121.0								
	DIMETHYLDIETHOXYSILANE			148.28	114-5	(-97)	0.8395	1.3805	
CH <sub>3</sub>	$C_6H_{16}O_2Si$			Flashpoint: 11	- ( - )				
O-Si-OC <sub>2</sub> H <sub>5</sub>	Viscosity: 0.53 cSt	_		TOXICITY: ο ΔHform: 200	ral rat, LDLo: 1,000	mg/kg			
CH	Vapor pressure, 25°: 15 mn Dipole moment: 1.39	П		ΔH/vap: 9.8 k					
	Coefficient of thermal expan	nsion: 1.3 x 10 <sup>-3</sup>		ΔHcomb: -1,					
	Hydrophobic surface treatm		nt	ΔΠCOIIID1,	113 KGal/IIIOIE				
	HYDROLYTIC SENSITIVITY: 7:								
	[78-62-6] TSCA	EC 201-127-6	HMIS: 2-4-1-X		100g	2kg		15kg	
	SID4123.0								
	DIMETHYLDIMETHOXYSILANE	, 96%		120.22	82	(-80)	0.8646	1.3708	
CH <sub>3</sub>	$C_4H_{12}O_2Si$	Contains methanol		Flashpoint: -8	°C (18°F)				
o-si-ocii,	Viscosity, 20°: 0.44 cSt				ral rat, LD50: >2,00	0 mg/kg			
CH <sub>3</sub>	Vapor pressure, 36°: 100 m			•	emperature: 325°				
0.000	Coefficient of thermal expan			ΔHcomb: 832					
	Dipole moment: 1.33 deby Provides hydrophobic surfa		or nhase applications	ΔHform: 171	kcal/mole				
	HYDROLYTIC SENSITIVITY: 7:								
	[1112-39-6] TSCA	EC 214-189-4	HMIS: 3-4-1-X		25g	2kg		15kg	
CH <sub>3</sub>	SID4123.1								
-Si-OCH	DIMETHYLDIMETHOXYSILANE	:, 99+%		120.22	82	(-80)	0.8646	1.3708	
ar Octi,	DMDMOS					,			
CH <sub>2</sub>	HYDROLYTIC SENSITIVITY: 7:								
	[1112-39-6] TSCA	EC 214-189-4	HMIS: 3-4-1-X		500g				
	SID4125.0			40.4.00				4.0000	
	DIMETHYLETHOXYSILANE			104.22	54-5		0.757	1.3683	
	C <sub>4</sub> H <sub>12</sub> OSi			Flashpoint: 15	o°C (59°F) ral rat, LD50: 5,000	ma/ka		A	
	Undergoes hydrosilylation r	reactions		Vapor pressu				A	
	Oridorgood riyaroonyidalori i				0, 20 . 20 ! !!!!!			Contract of the second	
ÇH <sub>3</sub>	Waterproofing agent for spa	ace shuttle thermal til	es.1		0, 20 . 201 11111			- 47	
ÇH <sub>3</sub> H=Şi=OC <sub>3</sub>	Waterproofing agent for spa 1. Hill, W. et al. <i>Polym. Mate</i>	er. Sci. Eng. <b>1990,</b> 62	2, 668.		0, 20 . 20 ! !!!!!				
H-Si-OC <sub>2</sub> CH <sub>1</sub>	Waterproofing agent for spa 1. Hill, W. et al. <i>Polym. Mat</i> HYDROLYTIC SENSITIVITY: 7:	er. Sci. Eng. <b>1990</b> , 62 reacts slowly with moist	2, 668. ture/water			100		K	7
СН <sub>3</sub> СН <sub>3</sub>	Waterproofing agent for spa 1. Hill, W. et al. Polym. Mat- HYDROLYTIC SENSITIVITY: 7: [14857-34-2] TSCA	er. Sci. Eng. <b>1990,</b> 62	2, 668.		25g	100g			7
H-Si-OC <sub>2</sub> CH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather HydroLyTic Sensitivity: 7: [14857-34-2] TSCA SID4210.0	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7	2, 668. ture/water		25g	100g			7
H-Si-OC <sub>2</sub> CH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Hydrolytic Sensitivity: 7: [14857-34-2] TSCA SID4210.0 DIMETHYLMETHOXYCHLORO:	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7	2, 668. ture/water	124.64	25g 77	100g	0.953 <sup>25</sup>	1.3865	7
н-si-ос <sub>2</sub> сн <sub>3</sub> сн <sub>3</sub> г <sub>3</sub> о-si-сі	Waterproofing agent for spatial 1. Hill, W. et al. Polym. Mathematical Hydrocytic Sensitivity: 7:  [14857-34-2] TSCA SID4210.0 DIMETHYLMETHOXYCHLORO: C <sub>3</sub> H <sub>9</sub> CIOSi	er. Sci. Eng. 1990, 62 r reacts slowly with moist EC 238-921-7	2, 668. ture/water HMIS: 2-4-1-X	124.64 Flashpoint: -9	25g 77	100g	0.953 <sup>25</sup>	1.3865	7
H-Si-OC <sub>2</sub> CH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 r reacts slowly with moist EC 238-921-7	2, 668. ture/water HMIS: 2-4-1-X	124.64 Flashpoint: -9	25g 77 °C (16°F)		0.953 <sup>25</sup>	1.3865	7
H-\$i-OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 r reacts slowly with moist EC 238-921-7	2, 668. ture/water HMIS: 2-4-1-X	124.64 Flashpoint: -9	25g 77	100g 100g	0.953 <sup>25</sup>	1.3865	7
H-\$i-OC <sub>2</sub> CH <sub>3</sub> ÇH <sub>3</sub> CH <sub>5</sub> CH <sub>5</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90%	2, 668. ture/water HMIS: 2-4-1-X ture, water, protic solvent HMIS: 3-4-1-X	124.64 Flashpoint: -9 s	25g 77 °C (16°F) 25g				7
II—\$i—OC <sub>2</sub> CH <sub>3</sub> ÇH <sub>3</sub> I <sub>3</sub> O-\$i—Cl CH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90%	2, 668. ture/water HMIS: 2-4-1-X ture, water, protic solvent HMIS: 3-4-1-X	124.64 Flashpoint: -9 s	25g 77 °C (16°F) 25g		0.953 <sup>25</sup>	1.3865	7
H-\$i-OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> G-\$i-Cl CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with mois	ture/water HMIS: 2-4-1-X ture, water, protic solvent HMIS: 3-4-1-X	124.64 Flashpoint: -9 s	25g 77 °C (16°F) 25g				7
II—\$i—OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O-\$i—CI CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with mois	ture/water HMIS: 2-4-1-X ture, water, protic solvent HMIS: 3-4-1-X	124.64 Flashpoint: -9 s	25g 77 °C (16°F) 25g		1.010		7
H-\$i-OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> H <sub>3</sub> O-\$i-Cl CH <sub>3</sub> OCH <sub>3</sub> Si-O-\$i-CH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with mois  YDISILOXANE, 95% reacts slowly with moist	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X	124.64 Flashpoint: -9 s	25g 77 °C (16°F) 25g 165 9°C (86°F)	100g	1.010		7
H-\$i-OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> H <sub>3</sub> O-\$i-Cl CH <sub>3</sub> OCH <sub>3</sub> Si-O-\$i-CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Hydrolytic Sensitivity: 7: [14857-34-2] TSCA SID4210.0 DIMETHYLMETHOXYCHLORO: C <sub>3</sub> H <sub>9</sub> ClOSi HYDROLYTIC SENSITIVITY: 8: [1825-68-9] TSCA SID4236.0 1,3-DIMETHYLTETRAMETHOX' C <sub>6</sub> H <sub>19</sub> O <sub>5</sub> Si <sub>2</sub> HYDROLYTIC SENSITIVITY: 7: [18186-97-5] TSCA SID4400.0 DI-n-OCTYLDICHLOROSILANE	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X	124.64 Flashpoint: -9 s	25g 77 °C (16°F) 25g 165 9°C (86°F)	100g	1.010		7
H-Si-OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Proposition 1. STA 1.	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	2, 668. ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30	25g 77 °C (16°F) 25g 165 0°C (86°F)	100g	1.010		7
H-Si-OC <sub>2</sub> CH <sub>3</sub> CCH <sub>3</sub>	Waterproofing agent for spatial to the spatial to t	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	2, 668. ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30	25g 77 °C (16°F) 25g 165 0°C (86°F) 10g 145 / 0.2	100g 50g	1.010		7
II—\$i—OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O—\$i—Cl CH <sub>3</sub> CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> i—O—\$i—CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Hydrolytic Sensitivity: 7: [14857-34-2] TSCA SID4210.0 DIMETHYLMETHOXYCHLORO: C <sub>3</sub> H <sub>3</sub> ClOSi HYDROLYTIC SENSITIVITY: 8: [1825-68-9] TSCA SID4236.0 1,3-DIMETHYLTETRAMETHOX' C <sub>6</sub> H <sub>18</sub> O <sub>5</sub> Si <sub>2</sub> HYDROLYTIC SENSITIVITY: 7: [18186-97-5] TSCA SID4400.0 DI-n-OCTYLDICHLOROSILANE C <sub>16</sub> H <sub>34</sub> Cl <sub>2</sub> Si HYDROLYTIC SENSITIVITY: 8: [18416-07-4]	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	2, 668. ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30	25g 77 °C (16°F) 25g 165 0°C (86°F)	100g	1.010		7
CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O-Si-Cl CH <sub>3</sub> CH <sub>3</sub> i-O-Si-CH <sub>3</sub> i-O-Si-CH <sub>3</sub> CH <sub>3</sub> CH <sub>2</sub> CH <sub>3</sub> CCI CH <sub>2</sub> CCI	Waterproofing agent for spatial to the spatial terms of the spatial term	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	2, 668. ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 0°C (86°F) 10g 145 / 0.2 25g	100g 50g	0.940	1.3834	7
II—\$i—OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O—\$i—Cl CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> i—O—\$i—CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> CH <sub>2</sub> OCH <sub>3</sub> OCH <sub>3</sub>	Waterproofing agent for spatial to the spatial terms of the spatial term	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	2, 668. ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30	25g 77 °C (16°F) 25g 165 0°C (86°F) 10g 145 / 0.2	100g 50g	1.010		7
CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O-Si-Cl CH <sub>3</sub> CH <sub>3</sub> i-O-Si-CH <sub>3</sub> i-O-Si-CH <sub>3</sub> CH <sub>3</sub> CH <sub>2</sub> CH <sub>3</sub> CCI CH <sub>2</sub> CCI	Waterproofing agent for spatial to the spatial terms of the spatial term	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	2, 668. ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 0°C (86°F) 10g 145 / 0.2 25g	100g 50g	0.940	1.3834	7
п−si−ос₂ сн₃ сн₃ п₃о-si−сі сн₃ осн, осн₃ si−о−si−сн₃ осн₃ осн₃ сн₂ы сі	Waterproofing agent for spatial to the spatial terms of the spatial term	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 0°C (86°F) 10g 145 / 0.2 25g	100g 50g	0.940	1.3834	7
н−si−ос₂ сн₃ сн₃ н₃о-si−сі сн₃ осн₃ осн₃ si−о−si−сн₃ осн₃ осн₃ сн₂ы, сі сн₂ы, сі	Waterproofing agent for spatial to the spatial state of the spatial stat	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 0°C (86°F) 10g 145 / 0.2 25g	100g 50g	0.940	1.3834	7
CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O-Si-Cl CH <sub>3</sub> CH <sub>3</sub> i-O-Si-CH <sub>3</sub> i-O-Si-CH <sub>3</sub> CH <sub>3</sub> CH <sub>2</sub> CH <sub>3</sub> CCI CH <sub>2</sub> CCI	Waterproofing agent for spatial to the spatial state of the spatial stat	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X  ture, water, protic solvent HMIS: 3-2-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 9°C (86°F) 10g 145 / 0.2 25g	100g 50g	0.940	1.3834	7
CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> I <sub>3</sub> O-Si-Cl  CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> i-O-Si-CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> CH <sub>2</sub> ) <sub>7</sub> Si  Cl  Si  OCH <sub>3</sub> OCH <sub>4</sub> OCH <sub>5</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Hydrolytic Sensitivity: 7: [14857-34-2] TSCA SID4210.0 DIMETHYLMETHOXYCHLORO: C <sub>3</sub> H <sub>9</sub> CIOSi HYDROLYTIC SENSITIVITY: 8: [1825-68-9] TSCA SID4236.0 1,3-DIMETHYLTETRAMETHOX'C <sub>9</sub> H <sub>19</sub> O <sub>9</sub> Si <sub>2</sub> HYDROLYTIC SENSITIVITY: 7: [18186-97-5] TSCA SID4400.0 DI-n-OCTYLDICHLOROSILANE C <sub>10</sub> H <sub>34</sub> Cl <sub>2</sub> Si HYDROLYTIC SENSITIVITY: 8: [18416-07-4] SID4400.4 DI-n-OCTYLDIMETHOXYSILAN C <sub>19</sub> H <sub>40</sub> O <sub>2</sub> Si Hydrophobic surface treatm HYDROLYTIC SENSITIVITY: 7: [947155-81-9] SID4401.0 (DI-n-OCTYLMETHYLSILYL)ETI	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8  reacts rapidly with moist EC 242-074 reacts rapidly with moist reacts rapidly with moist reacts rapidly with moist	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X  ture, water, protic solvent HMIS: 3-2-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 9°C (86°F) 10g 145 / 0.2 25g	100g 50g	0.940	1.3834	7
CH <sub>3</sub> CH	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Proposition of the Proposit	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8  reacts rapidly with moist EC 242-074 reacts rapidly with moist reacts rapidly with moist reacts rapidly with moist	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X  ture, water, protic solvent HMIS: 3-2-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 °C (86°F) 10g 145 / 0.2 25g 132-4 / 0.2	100g 50g	0.940 0.854	1.3834	7
CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> CH <sub>2</sub> CH <sub>3</sub> CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> CH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Proposition of the Proposit	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8  reacts rapidly with moist E reacts rapidly with moist E reacts slowly with moist HYLDIMETHYLCHLC	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X  ture, water, protic solvent HMIS: 3-2-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 °C (86°F) 10g 145 / 0.2 25g 132-4 / 0.2	100g 50g	0.940 0.854	1.3834	7
H—Si—OC <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> H <sub>3</sub> O—Si—Cl CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> Si—O—Si—CH <sub>3</sub> OCH <sub>3</sub> OCH <sub>3</sub> CH <sub>2</sub> ) <sub>7</sub> Cl CH <sub>2</sub> Cl CH <sub>2</sub> ) <sub>7</sub> Cl CH <sub>2</sub> Cl	Waterproofing agent for spatial to the spatial	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8  reacts rapidly with moist E reacts rapidly with moist E reacts slowly with moist HYLDIMETHYLCHLC	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X  ture, water, protic solvent HMIS: 3-2-1-X	124.64 Flashpoint: -9 s 226.38 Flashpoint: 30 325.44	25g 77 °C (16°F) 25g 165 °C (86°F) 10g 145 / 0.2 25g 132-4 / 0.2	100g 50g	0.940 0.854	1.3834	7
CH <sub>3</sub> CCH <sub>3</sub>	Waterproofing agent for span 1. Hill, W. et al. Polym. Mather Proposition of the Proposit	er. Sci. Eng. 1990, 62 reacts slowly with moist EC 238-921-7  SILANE, 90% reacts rapidly with moist YDISILOXANE, 95% reacts slowly with moist EC 242-072-8  reacts rapidly with moist E reacts rapidly with moist HYLDIMETHYLCHLC everse phase chroma	ture/water HMIS: 2-4-1-X  ture, water, protic solvent HMIS: 3-4-1-X  ture/water HMIS: 3-3-1-X  ture, water, protic solvent HMIS: 3-2-1-X	124.64 Flashpoint: -9 s  226.38 Flashpoint: 30  325.44 s  316.60	25g 77 °C (16°F) 25g 165 °C (86°F) 10g 145 / 0.2 25g 132-4 / 0.2	100g 50g	0.940 0.854	1.3834	7

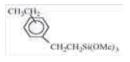
r	ame	ı	MW	bp/mm (r	np)		$D_4^{20}$	$n_{\scriptscriptstyle D}^{^{20}}$	
_	SID4401.5								
Hig Signification of	(DI-n-OCTYLMETHYLSILYL)ETHYLTRICHLOROSILA	NE	432.06	166-8 / 0.1			0.966		
~~~ h	$C_{19}H_{41}CI_3Si_2$								
	Forms bonded phases for reverse phase HPLC HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moist		_						
	[475213-02-6]	HMIS: 3-2-1-X	S	25g					
	SID4404.0								
çu, çu,	1,3-DI-n-OCTYLTETRAMETHYLDISILAZANE		357.77	160-5 / 1			0.826	1.4500	
CH94-21-24-21-(CH94CH)	C <sub>20</sub> H <sub>47</sub> NSi <sub>2</sub>			110°C (>230°F)					
201 90	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moistu	ıre/water	•	, ,					
	[69519-51-3]	HMIS: 2-1-0-X		10g					
	SID4510.0								
	DIPHENYLDICHLOROSILANE, 95%		253.20	304-5	(-22)		1.2216	1.5819	
^	C <sub>12</sub> H <sub>10</sub> Cl <sub>2</sub> Si Viscosity, 25°: 4.1 cSt		Flashpoint: 15	57°C (314°F) or mouse, LD50: 383	R ma/ka				
	Dipole moment: 2.6 debye		Vapor pressu		, mg/kg				
Si	Coefficient of thermal expansion: 0.7 x 10 <sup>-3</sup>		ΔHvap: 15.0						
COY CI	7		Specific heat:						
$\bigcirc$	Silicone monomer		opodino modili	o.oo oag.					
	Forms diol on contact with water								
	See also SID4588.0								
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moist		S	400-		Olem		001	
	[80-10-4] TSCA EC 201-251-0	HMIS: 3-1-1-X		100g		2kg		20kg	
	SID4510.1		050.00	224.5	( 00)		4.0040	4.5040	
OL a	DIPHENYLDICHLOROSILANE, 99% C <sub>12</sub> H <sub>10</sub> Cl <sub>2</sub> Si		253.20 Flashpoint: 15	304-5	(-22)		1.2216	1.5819	
Si,	0121 11001201			or mouse, LD50: 383	3 ma/ka				
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moist	ure, water, protic solvent							
<b>&gt;</b>	[80-10-4] TSCA EC 201-251-0	HMIS: 3-1-1-X		25g		100g		2kg	
^	SID4525.0								
	DIPHENYLDIETHOXYSILANE		272.42	167 / 15			1.0329	1.5269	
Si, OC <sub>2</sub> II <sub>1</sub>	$C_{16}H_{20}O_2Si$		Flashpoint: 17	75°C (347°F)					
OC-III	Vapor pressure, 125°: 2 mm	and LIV registeres							
$\bigcirc$	Provides hydrophobic coatings with good thermal HYDROLYTIC SENSITIVITY: 7: reacts slowly with moistu								
	[2553-19-7] TSCA EC 219-860-5	HMIS: 2-1-0-X		25g		100g		2kg	
	SID4535.0								
	DIPHENYLDIMETHOXYSILANE		244.36	161 / 15			1.0771	1.5447	
OCH	$C_{14}H_{16}O_2Si$		Flashpoint: 12	21°C (250°F)					
OCH	Viscosity, 25°: 8.4 cSt								
	Intermediate for high temperature silicone resins								
~	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moistu [6843-66-9] TSCA EC 229-929-1	HMIS: 3-1-1-X		100g		2kg			
	SID4552.0	111110.0117		1009		Ling			
	DIPHENYLMETHYLCHLOROSILANE		232.78	295	(-22)		1.128	1.5742	
	C <sub>13</sub> H <sub>13</sub> ClSi		Flashpoint: 14		(-22)		1.120	1.0742	
CH <sub>3</sub>	Viscosity: 5.3 cSt			re, 125°: 3 mm					
Si, au	Surface tension: 40.0 mN/m		ΔHvap: 149 l						
		1	Thermal cond	uctivity: 0.112 W/m	r'C				
~	α-silylates esters, lactones; precursors to silyl end 1. Larson, G. et al. J. Am. Chem. Soc. <b>1981</b> , 103								
	F&F: Vol. 10, p 91; Vol. 12, p 321; Vol. 13, p 74.	, 2410.							
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moist	ure, water, protic solvents	s						
	[144-79-6] TSCA EC 205-639-0	HMIS: 3-1-1-X		25g		100g		2.5kg	
	SID4552.5								
Cu, cu,	DIPHENYLMETHYL(DIMETHYLAMINO)SILANE		241.41	98-9 / 0.25			1.011		
NICH JE	C <sub>15</sub> H <sub>19</sub> NSi								
0	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moistu			05		400			
	[68733-63-1] TSCA	HMIS: 3-3-1-X		25g		100g			
	SID4553.0		0.40.00		,		4 * * *	4 = 4 + 25	
(C)	DIPHENYLMETHYLETHOXYSILANE		242.39	100-2 / 0.3	(-27)		1.018	1.5440 25	
× Ssi.	C <sub>15</sub> H <sub>18</sub> OSi Viscosity, 25°: 6.5 cSt		Flashpoint: 16	75°C (329°F) re, 125°: 3 mm					
OC2H8	v100051ty, 20 . 0.0 00t		ΔHvap: 14.8						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moistu	ıre/water	ap. 11.0						
	[1825-59-8] EC 217-368-5	HMIS: 2-0-0-X		10g		50g			
-	SID4586.0			<u></u>					
CH2	1,3-DIPHENYLTETRAMETHYLDISILAZANE		285.54	96-9 / 0.1			0.985	1.5384	
(C) - III	$C_{16}H_{23}NSi_2$		Flashpoint: 16	62°C (324°F)					
A 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moistu	ro/wator							
CH <sub>3</sub> 2	[3449-26-1] TSCA EC 222-372-5	HMIS: 3-1-1-X		5g		25g			

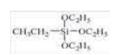


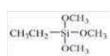




$$\begin{array}{c} \text{CH}_3\text{CH}_2\\ \\ \text{CH}_2\text{CH}_2\text{Si}-\text{Cl}\\ \\ \text{CH}_3\end{array}$$







name	MW	bp/mm (	mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$	
SIE4896.0 ETHYLMETHYLDICHLOROSILANE C <sub>3</sub> H <sub>6</sub> Cl <sub>2</sub> Si Dipole moment: 2.32 debye	143.09 Flashpoint: 2	100 2°C (36°F)			1.0630	1.4197	
HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solver	nts						
[4525-44-4] TSCA EC 224-860-3 HMIS: 3-4-1-X		25g	1	00g			
SIE4897.0 (ETHYLMETHYLKETOXIMINO)TRIMETHYLSILANE, 95% O-(TRIMETHYLSILYL)OXIME-2-BUTANONE C <sub>7</sub> H <sub>17</sub> NOSi	159.30	65 / 75			0.826 25	1.4125 <sup>25</sup>	
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water							
[37843-14-4] HMIS: 2-3-1-X		10g					
SIE4897.2 m,p-ETHYLPHENETHYLDIMETHYLCHLOROSILANE C <sub>12</sub> H <sub>19</sub> ClSi tech-95	226.82	100 / 0.4			1.00	1.520	
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [253279-88-8] HMIS: 3-2-1-X		5g					
SIE4897.5							
m,p-ETHYLPHENETHYLTRIMETHOXYSILANE, tech-95 $C_{13}H_{22}O_3Si$ Mixed isomers Component in optical hard coating resins	254.40 Flashpoint: 1	93-6 / 4 102°C (216°F)			0.996	1.4776 <sup>25</sup>	
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [259818-29-6] TSCA HMIS: 3-2-1-X		25g					
SIE4899.0		209					
ETHYLTRIACETOXYSILANE  C <sub>0</sub> H <sub>14</sub> O <sub>0</sub> Si  Liquid cross-linker for silicone RTVs	243.28 Flashpoint: 1	107-8 / 8 106°C (223°F)	(7-9)		1.143	1.4123	COMMERCIAL
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water							QA
[17689-77-9] TSCA EC 241-677-4 HMIS: 3-1-1-X		25g		2kg			
SIE4901.0 ETHYLTRICHLOROSILANE C <sub>2</sub> H <sub>6</sub> Cl <sub>3</sub> Si	163.51 Flashpoint: 2	` '	(-106)		1.237	1.4260	
Viscosity: 0.48 cSt Dipole moment: 2.1	Critical temp	oral rat, LD50: 1,330 ı ı: 287°	mg/kg				
Coefficient of thermal expansion: 1.5 x 10 <sup>-3</sup> Vapor pressure, 20°: 26 mm Vapor pressure, 30.4°: 66 mm	ΔHform: -20 ΔHvap: 9.0	kcal/mole					COMMERCIAL
Employed in the cobalt-catalyzed Diels-Alder approach to 1,3-disubst	ΔHfus: 7.0 k tituted and 1,2,		enes.1				AL
1. Hilt, G.; Danz, M. S <i>ynthesis</i> <b>2008</b> , 2257. F&F: Vol. 16, p 98.							
HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solver [115-21-9] TSCA EC 204-072-6 HMIS: 3-3-1-X	nts	25g	5	00g		4kg	
SIE4901.2				oog		ing .	
ETHYLTRIETHOXYSILANE	192.33	158-9	(-78)		0.896	1.3955	
$C_8H_{20}O_3Si$	Flashpoint: 4						
Viscosity: 0.70 cSt		oral rat, LD50: 13,720	0 0				
Vapor pressure, 50°: 10 mm	•	temperature: 235°C	(455 F)				
Coefficient of thermal expansion: 1.5 x 10 <sup>-3</sup> Specific heat: 0.43 cal/g/°	ΔHvap: 7.8	erature: 314° kcal/mole surfaces: 26.3 mN/n	n				
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	·						
[78-07-9] TSCA EC 201-080-1 HMIS: 3-2-1-X		100g	5	00g			
SIE4901.4	150.25	104.5			0.0400	1 2020	CC
ETHYLTRIMETHOXYSILANE $C_rH_{td}O_sSi$	Flashpoint: 27	124-5 7°C (81°F)			0.9488	1.3838	ХМХ
Viscosity: 0.5 cSt	ΔHcomb: 3,42						ÆR.
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	,						COMMERCIAL
[5314-55-6] TSCA EC 226-172-9 HMIS: 3-3-1-X		25g	2	kg		17kg	



Surface conductivity of glass substrates is reduced by application of Glassclad® 18. Surface arc-tracking is eliminated on fluorescent light bulbs

CE/CEACH/CH.	CH <sub>3</sub>
	CH <sub>4</sub>











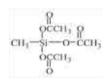
r	name	M	W	bp/mm (ı	mp)	D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
	PP1-GC18 GLASSCLAD® 18 OCTADECYL FUNCTIONAL SILANE, 20% in t-butanol/diaceto					0.88	
	Hazy, amber liquid yc of treated glass surface: 31 mN/m Coefficient of friction of treated glass surface: 0.2 - 0.3		ashpoint: 10°C our point: 4°C	(50°F)			
	Surface resistivity of treated surface: 1.2 x 10 <sup>13</sup> ohms Water-dispersible hydrophobic surface treatment						
	For application information see Gelest's Performance Product.	s Brochure					
on	Reduces blood protein adsorption. <sup>1</sup> 1. Arkles, B. et al. In Silanes Surfaces & Interfaces; Leyden, D	Ed: Gord	on & Breach: 1	086· n 01			
,,,,	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	., Lu, Ooru	on & Dieach. 1	300, p 31.			
	TSCA HMIS: 2-4-7	1-X		100g	1.5kg		15kg
5	SIH5840.4						
(	(HEPTADECAFLUORO-1,1,2,2-TETRAHYDRODECYL)-	54	10.72	197-8		1.51	1.3410
	DIMETHYLCHLOROSILANE Packaged of	over copper	powder				
	PERFLUORODECYL-1H,1H,2H,2H-DIMETHYLCHLOROSILANE						
(	C <sub>12</sub> H <sub>10</sub> CIF <sub>17</sub> Si						
	Derivatizing agent for fluorous phase synthesis HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, prot	ic solvents					
Γ	[74612-30-9] HMIS: 3-2-1			5g	25g		
	SIH5840.6			. 3	9		
(	(HEPTADECAFLUORO-1,1,2,2-TETRAHYDRODECYL)- METHYLDICHLOROSILANE Packaged o		S1.14 powder	205-7	(26-7)	1.630	1.345
	C <sub>11</sub> H <sub>7</sub> Cl <sub>2</sub> F <sub>17</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, prot		pondo				
ſ;	[3102-79-2] HMIS: 3-2-1			5g	25g		
_	SIH5841.0						
	(HEPTADECAFLUORO-1,1,2,2-TETRAHYDRODECYL)-	58	31.56	216-8		1.703	1.3490
	TRICHLOROSILANE Packaged of	ver copper	powder				
	PERFLUORODECYL-1H,1H,2H,2H-TRICHLOROSILANE						
(	$C_{10}H_4CI_3F_{17}Si$	TO	OXICITY: oral	rat, LD50: >5,00	0 mg/kg		
	yc of treated surfaces: 12 mN/m. <sup>1</sup>						
	<ol> <li>Brzoska, J. et al. Langmuir 1994, 10, 4367.</li> <li>HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, prot</li> </ol>	ic solvents					
Г	[78560-44-8] TSCA HMIS: 3-2-1			5g	25g		
_	SIH5841.2						
	(HEPTADECAFLUORO-1,1,2,2-TETRAHYDRODECYL)-	61	10.38	103-6 / 3		1.407 <sup>25</sup>	1.3419
	TRIETHOXYSILANE Packaged o			103-0 / 3		1.407	1.0410
	C <sub>16</sub> H <sub>19</sub> F <sub>17</sub> O <sub>3</sub> Si						
	Hydrolysis in combination with polydimethoxysiloxane gives had 1. Oota, T. et al. Jpn. Kokai JP 06,293,782, 1993; <i>Chem. Absti</i>						
	See also SIP6720.3						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water			<b>5</b>	25-		
	[101947-16-4] HMIS: 3-2-7	I-X		5g	25g		
	SIH5841.5		20.00				4 004 25
	(HEPTADECAFLUORO-1,1,2,2-TETRAHYDRODECYL)-		88.30	247		1.54	1.331 <sup>25</sup>
	TRIMETHOXYSILANE Packaged of $C_{13}H_{13}F_{17}O_3Si$	vei copper	howner			- W	Vater droplets on silicon wafe
	Treated surface contact angle, water: 115°						eated with SIH5841.5 exhibi
9	yc of treated surfaces: 12 mN/m				W W		igh contact angle
	Forms inorganic hybrids with photoinduceable refractive index 1. Park, JU. et al. <i>J. Mater. Chem.</i> <b>2003</b> , <i>13</i> , 738.	reduction.1					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
[	[83048-65-1] TSCA-S HMIS: 3-2-	1-X		5g	25g		
9	SIH5842.0						
	(3-HEPTAFLUOROISOPROPOXY)PROPYLTRICHLORO-	36	31.55	85-7 / 35		1.497	1.3710
	SILANE						
(	C <sub>6</sub> H <sub>6</sub> Cl <sub>3</sub> F <sub>7</sub> OSi						
	Specific wetting surface area: 356 m <sup>2</sup> /g						
	HYDDOLYTIC SENSITIVITY: 8: reacts rapidly with majeture, water, prot	ic solvents					
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, prot [15538-93-9] EC 239-589-6 HMIS: 3-3-			5g			

	name		MW	bp/mm (r	np)	D4 <sup>20</sup>	$n_{\scriptscriptstyle D}^{\scriptscriptstyle 20}$	
	SIH5842.2 3-(HEPTAFLUOROISOPROPOXY)PROPY TRIMETHOXYSILANE	L-	348.29	39 / 0.5			1.3841	
F <sub>3</sub> C F <sub>2</sub> C = O = CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> Si(OC F <sub>3</sub> C	Aligns liquid crystals. <sup>1</sup> 1. Jap. Pat. 57177121, 1982	surface: 109-112°						
	HYDROLYTIC SENSITIVITY: 7: reacts slow [19116-61-1]	ly with moisture/water HMIS: 3-2-1-X		10g				
70417	SIH5845.0			<u> </u>				
си сн <sup>4</sup> (сн <sup>5)9</sup> – гн <sup>2</sup> сі	n-HEPTYLMETHYLDICHLOROSILANE C <sub>8</sub> H <sub>18</sub> Cl <sub>2</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapic [18395-93-2] TSCA EC 242- SIH5846.0		•	207-8 66°C (151°F) 25g		0.978	1.4396 <sup>25</sup>	
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>6</sub> SiCl <sub>3</sub>	$\label{eq:n-heptyltrichlorosilane} $$ n-\text{Heptyltrichlorosilane} $$ C_7H_{15}Cl_3Si$                                     $	•		211-2 64°C (147°F)		1.087	1.4439 25	
	[871-41-0] TSCA EC 212- SIH5917.0	807-7 HMIS: 3-2-1-X		25g				
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>25</sub> SiCl <sub>3</sub>	$\begin{aligned} & \text{HEXACOSATRICHLOROSILANE, blend} \\ & \text{C}_{2e}\text{H}_{53}\text{Cl}_3\text{Si} & \text{Contains} \\ & \text{A distilled cut product with more repro} \end{aligned}$		500.15		(35-55)			
	HYDROLYTIC SENSITIVITY: 7: reacts slow	ly with moisture/water HMIS: 3-3-1-X		25g				
	[60085-14-5] SIH5918.0 HEXADECAFLUORODODEC-11-EN-1-YLT SILANE		589.61	94-6 / 0.6		1.626	1.3713	
H <sup>°</sup> C ⇒CHCL <sup>4</sup> CL <sup>5</sup> / <sup>0</sup> CL <sup>3</sup> CH <sup>3</sup> CH <sup>3</sup> SICI <sup>3</sup>	C <sub>12</sub> H <sub>7</sub> Cl <sub>3</sub> F <sub>16</sub> Si Forms self-assembled monolayers; re HYDROLYTIC SENSITIVITY: 7: reacts slow		IA	1.0g				
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>14</sub> CH <sub>2</sub> SiCl <sub>3</sub>	$\begin{split} & \text{SIH5920.0} \\ & \text{n-HEXADECYLTRICHLOROSILANE, 95\%} \\ & \text{C}_{\text{16}}\text{H}_{\text{33}}\text{CI}_{\text{3}}\text{Si} \\ & \text{yc of treated surfaces: 21 mN/m} \end{split}$		359.88 Flashpoint:	202 / 10 154°C (309°F)		0.98	1.4592	
	HYDROLYTIC SENSITIVITY: 8: reacts rapic   [5894-60-0]   TSCA   EC 227-   SIH5922.0		ents	25g	100g			
$\mathrm{CH_3(CH_2)_{14}CH_2Si(OC_2H_3)_3}$	HEXADECYLTRIETHOXYSILANE, 95% $C_{22}H_{46}O_3Si$ HYDROLYTIC SENSITIVITY: 7: reacts slow	ly with moisture/water	388.71	160-1 / 1	(-9)	0.888	1.4370	
	[16415-13-7] TSCA EC 240-	465-9 HMIS: 2-1-1-X		25g	100g			
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>14</sub> CH <sub>2</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	SIH5925.0  HEXADECYLTRIMETHOXYSILANE, 95%  C <sub>19</sub> H <sub>42</sub> O <sub>3</sub> Si  Viscosity: 7 cSt  Employed as rheology modifier for mo  Modifier for moisture crosslinkable pol		•	155 / 0.2 122°C (252°F) temperature: 245°C	(-1)	0.89	1.4356	COMMERCIAL
	Water scavenger HYDROLYTIC SENSITIVITY: 7: reacts slow	ly with moisture/water						7
H <sub>3</sub> C Si CH <sub>3</sub> CH <sub>3</sub> H <sub>3</sub> C CH <sub>3</sub>		A64-3 HMIS: 2-2-1-X  ZANE  I resistance.  I ligomer in presence of Ru/H <sub>2</sub> 1990, 11, 503.  1986; US Patent 4,788,309, em. 1980, 187, 21.	ΔHform: 13 Dielectric co	25g 186-8 51°C (142°F) 2 kcal/mole nstant, 1000Hz: 2.57	2kg (-10)	0.922	16kg 1.4448	COMMERCIAL
	HYDROLYTIC SENSITIVITY: 7: reacts slow [1009-93-4] TSCA EC 213-	ly with moisture/water		25g	100g		2kg	

	name	MW bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$	
	SIH6110.0					
	HEXAMETHYLDISILAZANE	161.39 126-7		0.7742	1.4080	
	HMDS, HMDZ	Flashpoint: 12°C (54°F)				
	$C_6H_{19}NSi_2$	TOXICITY: oral rat, LD50: 850 mg/kg				
	Vapor pressure, 50°: 50 mm	TOXICITY: ipr mouse, LDLo: 650 mg/kg	3			
	Viscosity: 0.90 cSt	ΔHcomb: 6,052 kcal/mole				
The state of the s	Dielectric constant: 1000 Hz: 2.27	ΔHvap: 8.3 kcal mole				
CH <sub>15</sub> II CH <sub>3</sub>	pKa: 7.55	Surface tension: 18.2 mN/m				5
CH <sub>3</sub> Si-N-Si-CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	Ea, reaction w/SiO <sub>2</sub> surface: 17.6 kcal/mole	Specific wetting surface: 485 m²/g Dipole moment: 0.37				COMMERCIAL
3,000	Versatile silylation reagent; creates hydrophobic surfaces					KCL
	Converts acid chlorides and alcohols to amines in a three-compon	ent reaction.'				F
	Reacts with formamide and ketones to form pyrimidines. <sup>2</sup>					
	1. Li, HH. et al. <i>Eur. J. Org. Chem.</i> <b>2008</b> , 3623.	2 7000				
	2. Tyagarajan, S. and Chakravarty, P. K. <i>Tetrahedron Lett.</i> <b>2005</b> , 4					
	F&F: Vol. 1, p 427; Vol. 2, p 159; Vol. 5, p 323; Vol. 6, p 273; Vol. 7	r, p 167; voi. 8, p 29; voi. 9, p 234;				
	Vol. 11, p 38; Vol. 12, p 239; Vol. 13, p 141; Vol. 14, p 300. HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	[999-97-3] TSCA EC 213-668-5 HMIS: 2-4-1-X	25g	1.5kg		14kg	
		209	1.org		1410	
	SIH6110.1	404.20		0.7740	4.4000	
447	HEXAMETHYLDISILAZANE, 99%	161.39 126-7		0.7742	1.4080	2
CH <sub>3</sub> H CH <sub>3</sub>	HMDS, HMDZ C <sub>6</sub> H <sub>19</sub> NSi <sub>2</sub>	TOXICITY: ipr mouse, LDLo: 650 mg/kg	1			J.M.A
CH <sub>3</sub> —Si-N-Si-CH <sub>3</sub>	<pre>C<sub>6</sub>H<sub>19</sub>NSI<sub>2</sub> </pre> <pre><pre><pre></pre> <pre></pre> <pre< td=""><td>TOATOTT I. IPI IIIOUSE, LDLO. 650 Mg/KQ</td><td>đ</td><td></td><td></td><td>A Es</td></pre<></pre></pre>	TOATOTT I. IPI IIIOUSE, LDLO. 650 Mg/KQ	đ			A Es
CH3 CH3	Photoresist adhesion promoter					COMMERCIAL
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					È
	[999-97-3] TSCA EC 213-668-5 HMIS: 2-4-1-X	25g	1.5kg			
	SIH6165.6	3	3			
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>4</sub> CU <sub>2</sub> ,CI	HEXYLMETHYLDICHLOROSILANE	199.19 204-6		0.993	1.439	
Si	C <sub>7</sub> H <sub>16</sub> Cl <sub>2</sub> Si	Flashpoint: 85°C (185°F)		0.555	1.433	
CH3 CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so					
	[14799-94-1] TSCA EC 238-864-8 HMIS: 3-2-1-X	25g				
	SIH6167.0	-				
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>4</sub> CH <sub>2</sub> , Cl	HEXYLTRICHLOROSILANE	219.61 191-2		1.107	1.3473	
C1 S1 C1	C <sub>6</sub> H <sub>13</sub> Cl <sub>3</sub> Si	Flashpoint: 85°C (185°F)				
C1	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so					
	[928-65-4] TSCA EC 213-178-1 HMIS: 3-2-1-X	25g	100g			
	SIH6167.5					
H <sub>3</sub> (CH <sub>2</sub> ) <sub>4</sub> CH <sub>2</sub> Si(OC <sub>2</sub> H <sub>4</sub> ) <sub>3</sub>	HEXYLTRIETHOXYSILANE	248.44 115 / 18		0.860	1.408 <sup>25</sup>	
	$C_{12}H_{28}O_3Si$	Flashpoint: 95°C (203°F)				
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	, , ,				
	[18166-37-5] HMIS: 2-1-1-X	25g	100g			
	SIH6168.5					_
	HEXYLTRIMETHOXYSILANE	206.35 202-3		0.911 25	1.4070	CO
H <sub>3</sub> (CH <sub>2</sub> ) <sub>4</sub> CH <sub>2</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	$C_9H_{22}O_3Si$	Flashpoint: 62°C (144°F)				M.M.
	Surface modification of TiO <sub>2</sub> pigments improves dispersion	, ,				COMMERCIAL
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					77
	[3069-19-0] TSCA EC 221-331-9 HMIS: 3-2-1-X	50g	2kg			
CH <sub>1</sub>	SII6452.5					
H <sub>2</sub> C (HCH Si = C)	ISOBUTYLDIMETHYLCHLOROSILANE	150.72 131-3		0.863	1.4187 25	
H-C CHCH291-CI	C <sub>6</sub> H <sub>15</sub> CISi	Flashpoint: 18°C (64°F)				
CH <sup>2</sup>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so					
	[27490-70-6] EC 248-493-3 HMIS: 3-4-1-X	10g				
H <sub>2</sub> C, CH <sub>3</sub>	SII6452.8		_			
	ISOBUTYLMETHYLDIMETHOXYSILANE	162.30 63 / 40		0.851	1.396	
CHCH-Si -OCH	100B011EME1111EBIME1110X1GIE/ANE					
CHCH <sub>2</sub> Si —OCH <sub>3</sub>	C <sub>7</sub> H <sub>18</sub> O <sub>2</sub> Si	Flashpoint: 38°C (100°F)				
CHCH <sub>2</sub> Si —OCH <sub>5</sub>	$\text{C}_7\text{H}_{18}\text{O}_2\text{Si}$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	. , ,				
CHCH <sub>2</sub> Si —OCH <sub>3</sub>	$C_7H_{18}O_2Si$	Flashpoint: 38°C (100°F)				
H <sub>2</sub> C OCH <sub>3</sub>	C <sub>7</sub> H <sub>18</sub> O <sub>2</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	. , ,				
CHCH <sub>2</sub> Si —OCH <sub>3</sub>	$ \begin{array}{lll} C_7H_{18}O_2Si \\ & \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ & \underline{[18293-82-8]} & \underline{\text{EC 242-171-6}} & \underline{\text{HMIS: 2-2-1-X}} \end{array} $	. , ,		1.162	1.4335	
H <sub>3</sub> C CHCH <sub>2</sub> Si — OCH <sub>3</sub> OCH <sub>3</sub> CHCH <sub>2</sub> Si — CI	$\begin{array}{ccc} \text{C}_7\text{H}_{18}\text{O}_2\text{Si} \\ \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ \underline{\text{[18293-82-8]}} & \text{EC 242-171-6} & \text{HMIS: 2-2-1-X} \\ \text{SII6453.0} \end{array}$	25g		1.162	1.4335	
H <sub>2</sub> C OCH <sub>3</sub>	$\begin{array}{ccc} C_7H_{18}O_2Si\\ & \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ \hline [18293-82-8] & \text{EC 242-171-6} & \text{HMIS: 2-2-1-X} \\ \hline SII6453.0\\ & \text{ISOBUTYLTRICHLOROSILANE} \end{array}$	25g 191.56 140 Flashpoint: 37°C (99°F)		1.162	1.4335	
H <sub>3</sub> C CHCH <sub>3</sub> SI — OCH <sub>3</sub> H <sub>3</sub> C CHCH <sub>2</sub> SI — CI	$\begin{array}{ccc} C_7H_{18}O_2Si\\ & \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ \hline [18293-82-8] & \text{EC 242-171-6} & \text{HMIS: 2-2-1-X} \\ \hline SII6453.0\\ & \text{ISOBUTYLTRICHLOROSILANE} \\ & C_4H_3CI_3Si & \\ \end{array}$	25g 191.56 140 Flashpoint: 37°C (99°F)	100g	1.162	1.4335	
H <sub>3</sub> C CHCH <sub>3</sub> SI — OCH <sub>3</sub> H <sub>3</sub> C CHCH <sub>2</sub> SI — CI	$\begin{array}{c} C_7H_{18}O_2Si\\ \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water}\\ \hline [18293-82-8] & EC \ 242-171-6 & HMIS: 2-2-1-X\\ \hline SII6453.0\\ \hline ISOBUTYLTRICHLOROSILANE\\ \hline C_4H_9CI_3Si\\ \hline HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so$	25g 191.56 140 Flashpoint: 37°C (99°F)	100g	1.162	1.4335	
H <sub>3</sub> C CHCH <sub>2</sub> Si — CI H <sub>3</sub> C CCHCH <sub>2</sub> Si — CI	$ \begin{array}{cccc} C_7H_{18}O_2Si \\ & \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ \hline [18293-82-8] & EC 242-171-6 & HMIS: 2-2-1-X \\ \hline SII6453.0 \\ & \text{ISOBUTYLTRICHLOROSILANE} \\ \hline & \text{C}_4H_9CI_3Si \\ & \text{HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so} \\ \hline [18169-57-8] & TSCA & EC 242-053-4 & HMIS: 3-3-1-X \\ \hline \end{array} $	25g 191.56 140 Flashpoint: 37°C (99°F)	100g	1.162	1.4335	
H <sub>3</sub> C CHCH <sub>2</sub> Si — CCH <sub>3</sub> H <sub>3</sub> C CHCH <sub>2</sub> Si — CI  H <sub>3</sub> C CI	$ \begin{array}{cccccccccccccccccccccccccccccccccccc$	25g  191.56 140 Flashpoint: 37°C (99°F) Ivents 25g	100g			COM
H <sub>3</sub> C CHCH <sub>2</sub> Si — OCH <sub>3</sub> H <sub>3</sub> C CHCH <sub>2</sub> Si — CI  H <sub>3</sub> C CI	$\begin{array}{cccc} C_7H_{18}O_2Si \\ & \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ \hline [18293-82-8] & EC 242-171-6 & HMIS: 2-2-1-X \\ \hline SII6453.0 \\ \hline ISOBUTYLTRICHLOROSILANE \\ \hline C_4H_9CI_3Si \\ \hline & \text{HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so} \\ \hline [18169-57-8] & TSCA & EC 242-053-4 & HMIS: 3-3-1-X \\ \hline SII6453.5 \\ \hline ISOBUTYLTRIETHOXYSILANE \\ \hline \end{array}$	25g  191.56 140 Flashpoint: 37°C (99°F) Ivents 25g  220.38 190-1	J			COMME
H <sub>3</sub> C CHCH <sub>2</sub> Si — OCH <sub>3</sub> H <sub>3</sub> C CHCH <sub>2</sub> Si — CI  H <sub>3</sub> C CI  H <sub>3</sub> C CI	$ \begin{array}{cccccccccccccccccccccccccccccccccccc$	25g  191.56 140 Flashpoint: 37°C (99°F) Ivents 25g  220.38 190-1 Flashpoint: 63°C (145°F)	J			COMMERCI
H <sub>3</sub> C CHCH <sub>2</sub> Si — OCH <sub>3</sub> H <sub>3</sub> C CHCH <sub>2</sub> Si — CI  H <sub>3</sub> C CHCH <sub>2</sub> Si — CI  H <sub>3</sub> C CHCH <sub>2</sub> Si — CI	$ \begin{array}{c} C_7H_{18}O_2Si \\ \text{HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water} \\ \hline [18293-82-8] & EC 242-171-6 & HMIS: 2-2-1-X \\ \hline SII6453.0 \\ \hline ISOBUTYLTRICHLOROSILANE \\ \hline C_4H_9CI_3Si \\ \hline \hline HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so } \\ \hline [18169-57-8] & TSCA & EC 242-053-4 & HMIS: 3-3-1-X \\ \hline SII6453.5 \\ \hline ISOBUTYLTRIETHOXYSILANE \\ \hline \hline C_{10}H_{24}O_3Si \\ \hline \end{array} $	25g  191.56 140 Flashpoint: 37°C (99°F) Ivents 25g  220.38 190-1 Flashpoint: 63°C (145°F)	J			COMMERCIAL

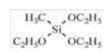
	name	MW	bp/mm (mp)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{_{\scriptscriptstyle 20}}$	
H <sub>3</sub> C OCH <sub>3</sub> CHCH <sub>2</sub> Si — OCH <sub>3</sub>	SII6453.7 ISOBUTYLTRIMETHOXYSILANE TRIMETHOXYSILYL-2-METHYLPROPANE C <sub>7</sub> H <sub>18</sub> O <sub>3</sub> Si	Viscosity: 0.8	ral rat, LD50: >2,000 mg/kg cSt	0.933	1.3960	
OCH3	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [18395-30-7] TSCA EC 242-272-5 HMIS: 3-2-1-X		ic surface	2kg	17kg	
TARCOL STROKES AND COMME	SII6456.6					_
CH <sub>2</sub> CH <sub>2</sub> CHCH <sub>2</sub> Si-Cl	$\begin{split} & \text{ISOOCTYLDIMETHYLCHLOROSILANE} \\ & \text{C}_{10}\text{H}_{23}\text{CISi} \\ & \text{HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solvents.} \end{split}$	206.83 ents	83-5 / 10	0.852		
CH <sub>3</sub> CH <sub>3</sub>	[79957-95-2] EC 279-358-7 HMIS: 3-3-1-X		25g			
ÇH₃ ÇH₃ CH₃ÇCH₂CHCH₂SiCl₃	SII6457.0 ISOOCTYLTRICHLOROSILANE 1-TRICHLOROSILYL-2,4,4-TRIMETHYLPENTANE C <sub>8</sub> H <sub>17</sub> Cl <sub>3</sub> Si	247.67 Flashpoint: 88	117 / 50 5°C (185°F)	1.0684	1.4510	
ĊĤ <sub>3</sub> :	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solve [18379-25-4] TSCA EC 242-262-0 HMIS: 3-2-1-X	ents	25g	100g		
CH <sub>3</sub> CH <sub>3</sub> QC <sub>2</sub> H <sub>5</sub> H <sub>3</sub> C CH <sub>2</sub> CHCH <sub>2</sub> Si-QC <sub>2</sub> H <sub>3</sub> CH <sub>3</sub> QC <sub>2</sub> H <sub>5</sub>	SII6457.5 ISOOCTYLTRIETHOXYSILANE  C <sub>14</sub> H <sub>32</sub> O <sub>3</sub> Si  Viscosity: 2.1 cSt  Vapor pressure, 112°: 10mm  Architectural water-repellent  Water scavenger for sealed lubricant systems	TOXICITY: or	236 (<-80) 55°C (>150°F) al rat, LD50: >2,000 mg/kg emperature: 265°C	0.880	1.4160	
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water		50g	Oka		
	[35435-21-3] TSCA EC 252-558-1 HMIS: 1-2-1-X SII6458.0		50g	2kg		-
CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>2</sub> Si(OCH <sub>3</sub> ) <sub>3</sub> CH <sub>3</sub>	$\begin{split} & \text{ISOOCTYLTRIMETHOXYSILANE} \\ & \text{$C_{11}$} \\ & \text{$H_{26}$} \\ & \text{$O_3$} \\ & \text{$V$iscosity: 2 cSt.} \\ & \text{$Component in Anti-Graffiti coatings} \end{split}$	234.41 Flashpoint: 52 Autoignition to	90 / 10 2°C (126°F) emperature: 310°C	0.887	1.4176	
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water           [34396-03-7]         TSCA         EC 251-995-5         HMIS: 3-2-1-X           SII6462.0		25g	100g	2kg	
H <sub>3</sub> C CH <sub>3</sub> CH <sub>3</sub>	$\begin{split} & \text{ISOPROPYLDIMETHYLCHLOROSILANE} \\ & \text{C}_5\text{H}_{12}\text{CISi} \end{split}$	136.69 Flashpoint: 1	114 5°C (59°F)	0.873	1.4138	
H <sub>3</sub> C ĊH <sub>3</sub>	See also SID4065.0  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solve [3634-56-8] TSCA HMIS: 3-4-1-X	ents	25g	100g		
	SIM6492.4 3-(p-METHOXYPHENYL)PROPYLMETHYLDICHLORO-	263.24	115-6 / 0.3	1.13		
-CHARLES -CH	SILANE $ C_{11}H_{16}Cl_2OSi \\  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solven and the second of the second of$	Flashpoint: >	110°C (>230°F)			
	[134438-26-9] HMIS: 3-1-1-X	store <5°C	25g			
	SIM6492.5 3-(p-METHOXYPHENYL)PROPYLTRICHLOROSILANE C <sub>10</sub> H <sub>13</sub> Cl <sub>3</sub> OSi		128-9 / 1 110°C (>230°F)	1.226		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solve [163155-57-5] HMIS: 3-1-1-X	enis	25g			
CH <sub>3</sub> O <sub>C</sub> CH <sub>3</sub>	SIM6492.8 (1-METHOXY-2-PROPOXY)TRIMETHYLSILANE ${\rm C_7H_{16}O_2Si}$ Viscosity: 2 cSt	162.30 Flashpoint: 20	132 (-40) 0°C (68°F)	0.83	1.3965	
rije—si-cii, cii,	Vapor pressure, 50°: 30 mm  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [55816-62-1] HMIS: 3-4-1-X  SIM6511.0		25g			_
CHARLE CO	p-(METHYLPHENETHYL)METHYLDICHLOROSILANE, - 95%  (p-TOLYLETHYL)METHYLDICHLOROSILANE $C_{10}H_{14}Cl_{y}Si$ Mixed $o_{7}$ , $p_{7}$ isomers	233.21 Flashpoint: 95	103-5 / 2 5°C (203°F)	1.10	1.5100 <sup>25</sup>	
	α:β ~ 40:60  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solve [718635-97-3]/[63126-87-4]  TSCA-L HMIS: 3-1-1-X	ents	50g			





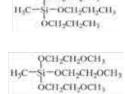












QCH2CH2CH3

name				MW	bp/mm	(mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{\scriptscriptstyle 20}$	
SILANE		)METHYLDICHLORO	)-	233.21	104-5 / 9			1.1165	1.5152	
C <sub>10</sub> H <sub>14</sub> Cl <sub>2</sub> Si		OICHLOROSILANE	·							
[13617-28-2]	TSCA	8: reacts rapidly with mo EC 237-102-1	isture, water, protic solve HMIS: 3-1-1-X	nts	25g		100g			
SIM6519.0	100/1	20 20. 102 .					.009			
METHYLTRIAC C <sub>7</sub> H <sub>12</sub> O <sub>6</sub> Si	CETOXYSILANE	r, 95%	re silicone RTVs	220.25 Flashpoint: 8 Vapor pressu	87-8 / 3 5°C (185°F) re, 94°: 9 mm	(40)		1.175	1.4083	COMMENCIAL
		7: reacts slowly with moi								141
[4253-34-3]	TSCA	EC 224-221-9	HMIS: 3-2-1-X		50g		2kg		18kg	
SIM6520.0										
CH <sub>3</sub> Cl <sub>3</sub> Si Viscosity: Vapor pres Surface te Ionization	essure, 13.5°: 10 ension: 20.3 mN potential: 11.36	/m			nl rat, LDLo: 450 pr emperature: 395° erature: 243° ure: 39 atm	(-78) om/4H		1.275	1.4110	COMMERCIAL
Specific h	eat: 0.22 cal/g/°									
HYDROLYT [75-79-6]	TIC SENSITIVITY:	8: reacts rapidly with mo EC 200-902-6	isture, water, protic solve HMIS: 3-4-2-X		25g	240 0 \( \text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\tint{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\tin}\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\ti}\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\tin}\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\tin}\tint{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\text{\texi}\tex{\text{\text{\ti}\}\tittt{\text{\text{\text{\text{\text{\text{\ti}\text{\text{\text{\text{\texi}\text{\text{\texi}\titt{\text{\ti}\tittt{\text{\text{\text{\text{\texi}\titt{\text{\texit{\text{\texi}\titt{\texi}\tittt{\texitit}\\\ \tittt{\text{\texi}\	500g	i.a	20kg	
CIMCEOO 4				" does not inclu	de container. zDR-S-0	)19 or ZCYL	S-019 req	quirea		
SIM6520.1 METHYLTRICH CH <sub>3</sub> Cl <sub>3</sub> Si	HLOROSILANE,	99%		149.48	66.4	(-78)		1.275	1.4110	
1. Josiek,	A. et al. Chem.	ms SiC by CVD. <sup>1</sup> Vap. Dep. <b>1996,</b> 2, 1 <sup>3</sup> 8: reacts rapidly with mo	7. isture, water, protic solve	nts						
[75-79-6]	TSCA	EC 200-902-6	HMIS: 3-4-2-X		25g		500g			
SIM6555.0										
Low cost I	0.6 cSt essure, 25°: 6 mm	face treatment		Autoignition t	142 O°C (86°F) ral rat, LD50: 12,50 emperature: 225°C nt: 1.72 debye			0.8948	1.3832	COMMERCIAL
[2031-67-6]	TSCA	7: reacts slowly with moi EC 217-983-9	sture/water HMIS: 1-3-1-X		25g		2kg		15kg	
SIM6560.0	100/	LO 217-303-3	TIIVIIO. 1-0-1-X		209		ZNY		Toky	
$\begin{array}{c} \text{METHYLTRIME} \\ \text{C}_4\text{H}_{12}\text{O}_3\text{Si} \\ \text{Viscosity:} \end{array}$	ETHOXYSILANE 0.50 cSt oment: 1.60 deb				ral rat, LD50: 12,50 emperature: 255°	(-78) 0 mg/kg		0.955	1.3696	COMMERCIAL
	ate for coating re									T.
HYDROLYT [1185-55-3]	TIC SENSITIVITY:	7: reacts slowly with moi EC 214-685-0	sture/water HMIS: 3-4-1-X		25g		2kg		17kg	
									9	
SIM6560.1	ETILOVVOII AND	- 000/		136.22				0.955	1.3696	
SIM6560.1 METHYLTRIME $C_4H_{12}O_3Si$ Viscosity: Dipole mo				Flashpoint: 8 TOXICITY: 0 Autoignition t	ral rat, LD50: 12,50 emperature: 255°	(-78) 0 mg/kg		0.000		
METHYLTRIME C <sub>4</sub> H <sub>12</sub> O <sub>3</sub> Si Viscosity: Dipole mo	0.50 cSt oment: 1.60 deb	ye		Flashpoint: 8' TOXICITY: 0	°C (46°F) ral rat, LD50: 12,50 emperature: 255°			0.000		
METHYLTRIME C <sub>4</sub> H <sub>12</sub> O <sub>3</sub> Si Viscosity: Dipole mo	0.50 cSt oment: 1.60 deb ate for coating re	ye	sture/water	Flashpoint: 8 TOXICITY: 0 Autoignition t	°C (46°F) ral rat, LD50: 12,50 emperature: 255°					
METHYLTRIME C <sub>4</sub> H <sub>12</sub> O <sub>3</sub> Si Viscosity: Dipole mo Intermedia HYDROLYT	0.50 cSt oment: 1.60 deb ate for coating re	ye	sture/water HMIS: 3-4-1-X	Flashpoint: 8 TOXICITY: 0 Autoignition t	°C (46°F) ral rat, LD50: 12,50 emperature: 255°		500g	0.000		
METHYLTRIME C <sub>4</sub> H <sub>12</sub> O <sub>3</sub> Si Viscosity: Dipole mo Intermedia HYDROLYT [1185-55-3] SIM6579.0 METHYLTRI-n- C <sub>10</sub> H <sub>24</sub> O <sub>3</sub> Si	0.50 cSt oment: 1.60 deb ate for coating re TIC SENSITIVITY: TSCA -PROPOXYSILA	ye esins 7: reacts slowly with moi EC 214-685-0	HMIS: 3-4-1-X	Flashpoint: 8 TOXICITY: 0 Autoignition t	°C (46°F) ral rat, LD50: 12,50 emperature: 255° 42 kcal/mole 100g 83-4 / 13		500g	0.878	1.4085	
METHYLTRIME C <sub>4</sub> H <sub>12</sub> O <sub>3</sub> Si Viscosity: Dipole mo  Intermedia HYDROLYT [1185-55-3] SIM6579.0 METHYLTRI-n- C <sub>10</sub> H <sub>24</sub> O <sub>3</sub> Si HYDROLYT	0.50 cSt oment: 1.60 deb ate for coating re TIC SENSITIVITY: TSCA -PROPOXYSILA TIC SENSITIVITY:	esins 7: reacts slowly with moi EC 214-685-0  NE 7: reacts slowly with moi	HMIS: 3-4-1-X	Flashpoint: 8 TOXICITY: α Autoignition t ΔHcomb: 1,1	°C (46°F) ral rat, LD50: 12,50 emperature: 255° 42 kcal/mole 100g 83-4 / 13 0°C (140°F)		500g		1.4085	
$\begin{tabular}{ll} METHYLTRIME $C_4H_{12}O_3Si$ & Viscosity: Dipole mo & Intermedia $HYDROLYT$ [1185-55-3] & SIM6579.0 & METHYLTRI-n-$C_{10}H_{24}O_3Si$ & HYDROLYT$ [5581-66-8] & \end{tabular}$	0.50 cSt oment: 1.60 deb ate for coating re TIC SENSITIVITY: TSCA -PROPOXYSILA	ye esins 7: reacts slowly with moi EC 214-685-0	HMIS: 3-4-1-X	Flashpoint: 8 TOXICITY: α Autoignition t ΔHcomb: 1,1	°C (46°F) ral rat, LD50: 12,50 emperature: 255° 42 kcal/mole 100g 83-4 / 13		500g		1.4085	
$\begin{tabular}{ll} METHYLTRIME $C_4H_{12}O_3Si$ & Viscosity: Dipole mo & Intermedia $HYDROLYT$ & [1185-55-3] & SIM6579.0 & METHYLTRI-n-$C_{10}H_{24}O_3Si$ & HYDROLYT$ & [5581-66-8] & SIM6585.0 & \end{tabular}$	0.50 cSt oment: 1.60 deb ate for coating re TIC SENSITIVITY: TSCA -PROPOXYSILA TIC SENSITIVITY:	esins 7: reacts slowly with moi EC 214-685-0  NE 7: reacts slowly with moi EC 226-978-0	HMIS: 3-4-1-X	Flashpoint: 8 TOXICITY: α Autoignition t ΔHcomb: 1,1	°C (46°F) ral rat, LD50: 12,50 emperature: 255° 42 kcal/mole 100g 83-4 / 13 0°C (140°F)		500g		1.4085	
$\label{eq:matter} \begin{split} \text{METHYLTRIME} \\ C_4 H_{12} O_3 \text{Si} \\ \text{Viscosity:} \\ \text{Dipole mo} \\ \text{Intermedia:} \\ \text{HYDROLYT} \\ [1185-55-3] \\ \text{SIM6579.0} \\ \text{METHYLTRI-n-} \\ C_{10} H_{24} O_3 \text{Si} \\ \text{HYDROLYT} \\ [5581-66-8] \\ \text{SIM6585.0} \\ \text{METHYLTRIS(I} \\ C_{10} H_{24} O_6 \text{Si} \\ \end{split}$	0.50 cSt oment: 1.60 deb ate for coating re TIC SENSITIVITY: TSCA -PROPOXYSILA TIC SENSITIVITY: TSCA METHOXYETHO	esins 7: reacts slowly with moi EC 214-685-0  NE 7: reacts slowly with moi EC 226-978-0	HMIS: 3-4-1-X sture/water HMIS: 2-2-1-X	Flashpoint: 8 TOXICITY: α Autoignition t ΔHcomb: 1,1  220.38 Flashpoint: 6	°C (46°F) ral rat, LD50: 12,50 emperature: 255° 42 kcal/mole  100g  83-4 / 13 0°C (140°F)  25g		500g	0.878		

	name	MW	bp/mm (	mp)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$	
H <sub>3</sub> C 1.CH C=N-O-Si-CH <sub>3</sub>	SIM6590.0  METHYLTRIS(METHYLETHYLKETOXIMO)SILANE, tech-95  METHYLTRIS(2-BUTANONEOXIME)SILANE  C <sub>13</sub> H <sub>27</sub> N <sub>3</sub> O <sub>3</sub> Si	301.46 Flashpoint: 90	110-1 / 2 )°C (194°F) ral rat, LD50: 2,000-	(-22)	0.982	1.4548 <sup>25</sup>	
10.15	Neutral cross-linker for condensation cure silicones HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [22984-54-9] TSCA EC 245-366-4 HMIS: 2-2-1-		100g	2kg			
CH <sub>2</sub> SiCl <sub>3</sub>	SIN6596.0 (1-NAPHTHYLMETHYL)TRICHLOROSILANE C <sub>11</sub> H <sub>a</sub> Cl <sub>3</sub> Si	275.64	150-1 / 7		1.3112	1.5974	
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic [17998-59-3] HMIS: 3-2-1-		10g				
Si(OCH <sub>2</sub> ),	SIN6597.0  1-NAPHTHYLTRIMETHOXYSILANE $C_{13}H_{16}O_3Si$ Employed in high refractive index surface modification	248.35	150 / 2	(33-5)		1.5562	
~~	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [18052-76-1] HMIS: 3-2-1-	X	5g				
CH <sub>2</sub> (CF <sub>2</sub> ) <sub>3</sub> CH <sub>2</sub> CH <sub>2</sub> - Si - Ct	SIN6597.3 NONAFLUOROHEXYLDIMETHYLCHLOROSILANE $C_8H_{10}CIF_9Si$ HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic	340.69	162-4		1.3422		
CH <sub>3</sub>	[119386-82-2] HMIS: 3-3-1- SIN6597.4	X	10g				
F <sub>2</sub> ) <sub>1</sub> CH <sub>2</sub> CH <sub>2</sub> = Si = N(CH <sub>3</sub> ) <sub>2</sub> CH <sub>3</sub>	NONAFLUOROHEXYLDIMETHYL(DIMETHYLAMINO)- SILANE $C_{10}H_{16}F_{9}NSi$	349.31 Flashpoint: 42	86-8 / 35 2°C (108°F)		1.214		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic HMIS: 3-3-1- SIN6597.6		10g				
CF <sub>2</sub> ) <sub>3</sub> CH <sub>2</sub> CH <sub>2</sub> -Si-Ci	NONAFLUOROHEXYLTRICHLOROSILANE $C_{c}H_{4}Cl_{5}F_{9}Si$	381.53	70-2 / 15		1.542		
CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic [78560-47-1] TSCA-L HMIS: 3-2-1-SIN6597.65		10g	50g			
OC <sub>2</sub> H <sub>5</sub> CF <sub>2</sub> ) <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> Si — OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>6</sub>	NONAFLUOROHEXYLTRIETHOXYSILANE  C <sub>12</sub> H <sub>19</sub> F <sub>5</sub> O <sub>3</sub> Si  Critical surface tension, treated surface: 23 mN/m  Oleophobic, hydrophobic surface treatment	410.35	96 / 15		1.201	1.3502	
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [102390-98-7] TSCA-L HMIS: 2-2-1- SIN6597.7	Х	25g	100g			
OCH <sub>3</sub> F <sub>235</sub> CH <sub>2</sub> CH <sub>2</sub> – Si – OCH <sub>3</sub>	NONAFLUOROHEXYLTRIMETHOXYSILANE  C <sub>9</sub> H <sub>13</sub> F <sub>9</sub> O <sub>3</sub> Si  Improves hydrolytic stability of dental composites. <sup>1</sup>	368.27	68-9 / 15		1.335	1.3376	
о́сн,	1. Nikei, S. et al. <i>J. Dent. Res.</i> <b>2002</b> , <i>81</i> (7), 482.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [85877-79-8] TSCA-L HMIS: 3-2-1-	·X	10g	50g			
OCILICIDENT OF COL	$\begin{array}{lll} {\rm SIN6598.0} \\ {\rm p\textsc{-}NONYLPHENOXYPROPYLDIMETHYLCHLOROSILANE} \\ {\rm C_{20}H_{35}CIOSi} & {\rm tech\textsc{-}95} \end{array}$	355.04	181 / 0.75		0.963	1.4925	
3449	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic HMIS: 3-1-1- SIO6615.0		10g				
ÇH <sub>3</sub> I <sub>3</sub> (CH <sub>2</sub> ) <sub>16</sub> CH <sub>2</sub> –Şi – CI	n-OCTADECYLDIMETHYLCHLOROSILANE	347.10 Flashpoint: 20	159 / 0.1 01°C (394°F)	(28-30)	0.856 29	1.4498 <sup>29</sup>	
CH <sub>3</sub>	Employed in bonded HPLC reverse phases. <sup>1</sup> 1. Wise, S. et al. In Silanes Surfaces & Interfaces; Leyden, D., I HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic [18643-08-8] TSCA EC 242-472-2 HMIS: 3-1-1-	solvents	: 1986; p349. 25g	2kg			
ÇH3 14CH314CH2 −\$i−Cl	SIO6615.1 n-OCTADECYLDIMETHYLCHLOROSILANE, 97% DIMETHYL-n-OCTADECYLCHLOROSILANE	347.10 Flashpoint: 20	159 / 0.1	(28-30)	0.856 <sup>29</sup>	1.4998 <sup>29</sup>	
сн <sub>з</sub>	$ \begin{array}{cccc} C_{20}H_{43}\text{CISi} & \text{Contains 3-6\% C}_{18} \text{ isomers} \\ \text{HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic} \\ [18643-08-8] & \text{TSCA} & \text{EC 242-472-2} & \text{HMIS: 3-1-1-1} \end{array} $	solvents	25g	100g			

	name				MW	bp/mm (ı	mp)	D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>	
	SIO6615.2									
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>16</sub> CH <sub>2</sub> -\$i - CI	n-OCTADECYLDIN 70% in toluene C <sub>20</sub> H <sub>43</sub> CISi	METHYLCHL	LOROSILANE Contains 5-10% (	C <sub>18</sub> isomers	347.10 Flashpoint: 5°	159 / 0.1 °C (41°F)		0.854		
CH <sub>3</sub>	HYDROLYTIC			pisture, water, protic solve	ents					
	[18643-08-8]	TSCA	EC 242-472-2	HMIS: 3-4-1-X		25g	2kg			
ÇH,	SIO6617.0	METHVI (DIN	METHYLAMINO)SILA	ANE	355.72	160 / 0.1		0.818	1.4512	
H <sub>2</sub> (CH <sub>2</sub> ) <sub>14</sub> CH <sub>2</sub> -Si-N(CH <sub>2</sub> ) <sub>2</sub>	C <sub>22</sub> H <sub>49</sub> NSi	WETTITE(DIN	Contains 5-10% (		000.12	100 / 0.1		0.010	1.4012	
Ċu <sub>x</sub>			7: reacts slowly with moi							
	[76328-77-3]	TSCA		HMIS: 3-3-1-X		10g	50g			
CH	SIO6618.0 n-OCTADECYLDIN	METHAI WE.	THOYVGII ANE		342.68	184-6 / 0.2		0.83 25	1.444	
H <sub>3</sub> (CH <sub>2</sub> ) <sub>18</sub> CH <sub>2</sub> - Si - ОСН <sub>3</sub> СН <sub>3</sub>	C <sub>21</sub> H <sub>46</sub> OSi Employed in	SAM resist. <sup>1</sup>	Contains 5-10% (	C <sub>18</sub> isomers nol., Sect. A <b>1999,</b> 33		164-6 / U.2		0.65	1.444	
			7: reacts slowly with moi			0.5	400			
	[71808-65-6] SIO6624.0	TSCA	EC 276-039-4	HMIS: 2-1-0-X		25g	100g			
CI		ETHOXYDIC:	HLOROSILANE, tech	1-95	383.51	144-7 / 1.5		0.94 25	1.452	
сп <sub>я</sub> сн <sub>э)в</sub> сн <sub>э</sub> - şi - осн <sub>1</sub> сі	C <sub>19</sub> H <sub>40</sub> Cl <sub>2</sub> OSi Maintains rea	activity of octa	Contains 5-10% (adecyltrichlorosilane,		l byproduct	144-77 1.5		0.54	1.402	
	[211934-50-8]			HMIS: 3-1-1-X		25g	100g			
20	SIO6625.0	ETLINA BLOCK			207.52	40-75-	(0.4.0)	0.000		
С1 Н3(СН2)14СН2 −Şi−СН3 С1	n-OCTADECYLME $C_{19}H_{40}Cl_2Si$ Viscosity: 7 of		LOROSILANE Contains 5-10% (	C <sub>18</sub> isomers		185 / 2.5 85°C (365°F) ral rat, LD50: 200-2,0 emperature: 230°C	(24-6) 000 mg/kg	0.930		
		SENSITIVITY: TSCA	8: reacts rapidly with mo EC 225-931-1	pisture, water, protic solve HMIS: 3-1-1-X	ents	25g	500g			
00.0	[5157-75-5] SIO6627.0	ISCA	EC 220-931-1	HIVIIS. 3-1-1-A		25g	500g			
OC <sub>2</sub> H <sub>5</sub> H <sub>2</sub> (CH <sub>2</sub> ) <sub>16</sub> CH <sub>2</sub> -\$i - CH <sub>3</sub>	n-OCTADECYLME	ETHYLDIETH	HOXYSILANE		386.73	197 / 2		0.852	1.4407	
OC <sub>2</sub> H <sub>5</sub>	$C_{23}H_{50}O_2Si$		Contains 5-10%	C <sub>18</sub> isomers		110°C (>230°F)				
171-2115			7: reacts slowly with moi			25~				
	[67859-75-0] SIO6629.0	TSCA	EC 267-423-2	HMIS: 2-1-0-X		25g				
осн,	n-OCTADECYLME	ETHYLDIME <sup>-</sup>	THOXYSILANE		358.68	190 / 3	(12-18)	0.85	1.4427	
H <sub>3</sub> (CH <sub>2</sub> ) <sub>16</sub> CH <sub>2</sub> -\$i - CH <sub>3</sub>	C <sub>21</sub> H <sub>46</sub> O <sub>2</sub> Si		Contains 5-10%	C <sub>18</sub> isomers		110°C (>230°F)	( 10)	****	=.	
OCH <sub>3</sub>	INDROLVER	OFNOITS ST	7	:	Autoignition to	emperature: 225°C				
	HYDROLYTIC ( [70851-50-2]	SENSITIVITY: TSCA	7: reacts slowly with moi EC 274-936-5	isture/water HMIS: 3-1-0-X		25g	100g			
	SIO6640.0	. 50/1	20 27 1 000 0			209	1009			
	n-OCTADECYLTR	RICHLOROSI	LANE, 95%		387.93	160-2 / 3	(22)	0.950 22	1.4602	
CIL	OTS		Contains 5-10%	C <sub>18</sub> isomers	Flashpoint: 18					
n con s cu =c=cu	C <sub>18</sub> H <sub>37</sub> Cl <sub>3</sub> Si Provides lipor	nhilic surface	e coatings							
113(C112)16(C112 -S1-C1			•	active molecular films.	1,2					
CI			lly active cell organelle							
	·		se electron transport							
			Met. <b>1997</b> , 85, 1375.							
			r <b>1997</b> , <i>13</i> , 3382.							
			Chem. <b>1976,</b> 250, 88 ater. Res. <b>2004,</b> 19, 2							
	See also SIO		ter. Nes. <b>2004</b> , 19, 2	303.						
	HYDROLYTIC :	SENSITIVITY:	8: reacts rapidly with mo	pisture, water, protic solve	ents					
	[112-04-9]	TSCA	EC 203-930-7	HMIS: 3-1-1-X		25g	1kg		15kg	
V-900	SIO6640.1				007.55			0.055 22		
ÇI	n-OCTADECYLTR C <sub>18</sub> H <sub>37</sub> Cl <sub>3</sub> Si	ICHLOROSI	ILANE Contains <3% C <sub>1</sub>	. isomers	387.93	160-2 / 3	(22)	0.950 22	1.4602	
H <sub>3</sub> (CH <sub>2</sub> ) <sub>16</sub> CH <sub>2</sub> -\$i-Cl		entration of t	terminal silane substit	-						
C1	•			pisture, water, protic solve	ents					
	[112-04-9]	TSCA	EC 203-930-7	HMIS: 3-1-1-X		25g	100g			
N200 SQ.	SIO6642.0				440 ===					
OC <sub>2</sub> H <sub>2</sub>	n-OCTADECYLTR	IETHOXYSIL		C isomore	416.76	165-9 / 2	(10-12)	0.87	1.4386	
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>14</sub> CH <sub>2</sub> -Si-OC <sub>2</sub> H <sub>3</sub>	C <sub>24</sub> H <sub>52</sub> O <sub>3</sub> Si Forms hydror	phobic, oleor	Contains 5-10% ( ohilic coatings	J <sub>18</sub> ISUITIELS	riasnpoint: >1	150°C (>302°F)				
OC <sub>2</sub> H <sub>3</sub>			7: reacts slowly with moi	isturo/wator						
	HYDROLYTIC	OLIVOITIVITI.	7. Todoto slowly with tho	isture/water						

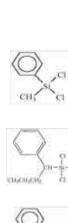
	name	MW	bp/mm (	(mp)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
	$\begin{split} & \text{SIO6645.0} \\ & \text{n-OCTADECYLTRIMETHOXYSILANE, 95\%} \\ & \text{C}_{\text{21}}\text{H}_{\text{46}}\text{O}_{\text{3}}\text{Si} & \text{Contains 5-10\% C}_{\text{18}} \text{ isomers} \end{split}$	374.68 Flashpoint: 1	170 / 0.1 40°C (284°F) ral rat, LD50: >5,00	(13-17) 0 ma/ka	0.885	1.439
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>18</sub> CH <sub>2</sub> -Si-OCH <sub>3</sub> OCH <sub>3</sub>	Forms hydrophobic, oleophilic coatings Forms clear, ordered films w/ tetramethoxysilane.  Undergoes oscillatory adsorption to form SAMs.  1. Shimjima, A. et al. <i>J. Am. Chem. Soc.</i> <b>1998</b> , <i>120</i> , 4528.  2. Thomsen, L. et al. <i>Surf. &amp; Interface Analysis</i> <b>2005</b> , 37, 472.			cgg		
	See also SIS6952.0 HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [3069-42-9] TSCA EC 221-339-2 HMIS: 2-1-1-X		25g	2kg		
	SIO6698.0 OCTAMETHYLCYCLOTETRASILAZANE	292.68	225	(97)	0.950 22	1.458 <sup>25</sup>
CH SI	$\begin{split} & \textit{OCTAMETHYLSILANETETRAMINE} \\ & C_{\text{B}} H_{\text{28}} N_{4} S i_{4} \\ & \textit{Forms } \alpha\text{-Si}_{3} N_{4} \text{ by ammonia thermal synthesis.}^{1} \\ & 1. \text{ Schaible, S. et al. } \textit{Applied Organomet. Chem. } \textbf{1993, } 7, 53. \end{split}$	Flashpoint: 6 ΔHform: 188	6°C (151°F)	(-,		
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [1020-84-4] TSCA EC 213-817-4 HMIS: 2-2-1-X		25g	100g		
H <sub>2</sub> C <sub>2</sub> CH <sub>3</sub> CH <sub>4</sub> CH <sub>2</sub> Si-Cl	$\begin{split} &\text{SIO6710.5} \\ &\text{n-OCTYLDIISOPROPYLCHLOROSILANE} \\ &\text{C}_{\text{14}}\text{H}_{\text{31}}\text{CISi} \\ &\text{Reagent for preparation of HPLC stationary phases w/ high stability} \end{split}$		95-9 / 0.5 110°C (>230°F)		0.875	1.4550
н <sub>і</sub> с сн	Kirkland, J. et al. <i>J. Chromatogr. Sci.</i> <b>1994</b> , <i>32</i> , 473.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [117559-37-2]  HMIS: 3-1-1-X		10g			
Сичен?⁄ен*-ы-мен?/ иче сич иче сич	SIO6710.7 n-OCTYLDIISOPROPYL(DIMETHYLAMINO)SILANE C <sub>16</sub> H <sub>37</sub> NSi HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	271.57	105 / 0.7		0.833	1.4560
H <sub>3</sub> C CH <sub>5</sub>	[151613-25-1] TSCA HMIS: 3-2-1-X SIO6711.0		25g			
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>6</sub> CH <sub>2</sub> - Si - CI CH <sub>3</sub>	n-OCTYLDIMETHYLCHLOROSILANE C <sub>10</sub> H <sub>23</sub> CISi HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solve	206.83 Flashpoint: 9		400	0.873	1.4328 <sup>25</sup>
CH	[18162-84-0] TSCA EC 242-044-5 HMIS: 3-1-1-X SIO6711.1		25g	100g		
СИ <sub>3</sub> (СИ <sub>2</sub> ) <sub>6</sub> СИ <sub>2</sub> —\$i—ОСИ <sub>3</sub> СИ <sub>3</sub>	n-OCTYLDIMETHYLMETHOXYSILANE $C_{11}H_{26}OSi$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [93804-29-6] EC 298-404-7 HMIS: 3-2-1-X	202.42 Flashpoint: 8	221-223 2°C (180°F) 25g		0.813	1.4230
СН <sub>3</sub> СН <sub>3</sub> (СН <sub>2)6</sub> СН <sub>2</sub> – Şi – N(СН <sub>3</sub> ) <sub>2</sub> СН <sub>4</sub>	SIO6711.3 n-OCTYLDIMETHYL(DIMETHYLAMINO)SILANE C <sub>12</sub> H <sub>28</sub> NSi HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	215.45 Flashpoint: 6	94-6 / 10 9°C (156°F)		0.80 25	1.4347
	[110348-62-4] HMIS: 3-2-1-X		25g			
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>6</sub> CH <sub>2</sub> . CI	SIO6712.0 n-OCTYLMETHYLDICHLOROSILANE $C_9H_{20}Cl_2Si$ HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solv	227.25 Flashpoint: 9	94 / 6 8°C (208°F)		0.9761	1.4440
	[14799-93-0] TSCA EC 238-863-2 HMIS: 3-2-1-X	51113	25g	500g		
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>6</sub> CH <sub>2</sub> , OC <sub>2</sub> H <sub>5</sub> H <sub>3</sub> C SI OC <sub>2</sub> H <sub>5</sub>	n-OCTYLMETHYLDIETHOXYSILANE  C <sub>19</sub> H <sub>30</sub> O <sub>2</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	246.47 Flashpoint: >	80-2 / 2 110°C (>230°F)		0.8478	1.4190
W. W. V.	[2652-38-2] HMIS: 2-1-0-X SIO6712.4		25g	100g		
OCH <sub>2</sub> CH <sub>2</sub> (CH <sub>2</sub> ) <sub>6</sub> CH <sub>2</sub> -Si-CH <sub>3</sub>	$\label{eq:noctyl} $$ n-OCTYLMETHYLDIMETHOXYSILANE $$ C_{11}H_{26}O_2Si$$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water$	218.42 Flashpoint: 9	87-9 / 5 4°C (201°F)		0.858	1.4190
OСН <sub>3</sub>	[85712-15-8] EC 288-374-3 HMIS: 3-2-1-X SIO6713.0		25g	100g		
CH₃(CH₂½,CH₂ −Şi−CI Cl	n-OCTYLTRICHLOROSILANE  C <sub>8</sub> H <sub>17</sub> Cl <sub>3</sub> Si  Vapor pressure, 125°: 1 mm	247.67 Flashpoint: 9	224-6 6°C (205°F)	(<-50)	1.0744	1.4490
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solv: [5283-66-9] TSCA EC 226-112-1 HMIS: 3-1-1-X	ents	25g	2kg		

	name	MW	bp/mm (ı	mp)	D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>	
	SIO6715.0						
	n-OCTYLTRIETHOXYSILANE	276.48	98-9 / 2	(<-40)	0.8750	1.4160	
OC <sub>2</sub> H <sub>5</sub>	$C_{14}H_{32}O_3Si$	Flashpoint: 1	09°C (228°F)	• •			
'H <sub>2</sub> ) <sub>6</sub> CH <sub>2</sub> -Si - OC <sub>2</sub> H <sub>3</sub>	Viscosity: 1.9 cSt	TOXICITY:	oral rat, LD50: >5,110	mg/kg			
OC-H	Widely used in architectural hydrophobation						
Orani.	May be formulated to stable water emulsions.1						
	1. Depasquale, R. et al. US Patent 4,648,904, 1987.						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
	[2943-75-1] TSCA EC 220-941-2 HMIS: 2-1-	0-X	50g	2kg		15kg	
	SIO6715.2					<u>-</u>	
/ CH <sub>3</sub> \	OCTYLTRIETHOXYSILANE, oligomeric hydrolysate				0.979		
(CH <sub>2</sub> ) <sub>6</sub>	Viscosity: 400-600 cSt						
CH <sub>2</sub> O-Si OC <sub>2</sub> H <sub>5</sub>	Reactive hydrophobic surface treatment with reduced volatile	by-products					
OC <sub>2</sub> H <sub>5</sub> /n	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	a) producto					
\ -23/	HMIS: 2-2-	1-X	100g				
		170	1009				
	SIO6715.5	004.44			0.007		
Cont	n-OCTYLTRIMETHOXYSILANE	234.41	191-2		0.907	1.417	
оси,	$C_{11}H_{26}O_3Si$	Flashpoint: 6					
CH <sub>2</sub> ) <sub>6</sub> CH <sub>2</sub> -Si = OCH <sub>3</sub>	Vapor pressure, 75°: 0.1 mm	Viscosity: 1	cSt				
OCH <sub>3</sub>	Treatment for particles used in non-aqueous liquid dispersion	S					
	See also SII6458.0 ISOCTYLTRIMETHOXYSILANE						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
	[3069-40-7] TSCA EC 221-338-7 HMIS: 3-1-	1-X	25g	2kg			
	SIP6716.0						
F	PENTAFLUOROPHENOXYUNDECYLTRIMETHOXY-	458.54					
$\preceq$	SILANE						
O(CH <sub>2</sub> ) <sub>11</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	C <sub>20</sub> H <sub>31</sub> F <sub>5</sub> O <sub>4</sub> Si						
F	For non-covalent immobilization of proteins						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
	[944721-47-5] HMIS: 3-2-	.1_X	5g				
		17					
4	SIP6716.4						
	PENTAFLUOROPHENYLPROPYLTRICHLOROSILANE	343.58	99 / 0.75	(27-30)	1.495	1.4620	
) — chich chisich	$C_9H_6CI_3F_5Si$						
1	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pro		_				
	[78900-02-4] HMIS: 3-1-	-1-X	2.5g				
77417	SIP6716.6						
<	PENTAFLUOROPHENYLPROPYLTRIMETHOXYSILANE	330.33	97 / 0.75		1.27		
)>-cn-cn-cn-shocn-h	$C_{12}H_{15}F_5O_3Si$						
~	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
J.	[303191-26-6] HMIS: 2-1-	1-X	2.5g				
	SIP6717.0		3				
ÇH <sub>3</sub> ÇH <sub>3</sub>						4 000 = 25	
	1,1,1,3,3-PENTAMETHYL-3-ACETOXYDISILOXANE	206.39	149-50		0.90	1.3887 25	
-o-si-o-si-cH <sub>1</sub>	C <sub>7</sub> H <sub>18</sub> O <sub>3</sub> Si <sub>2</sub>	Flashpoint: 4	ю°С (104°F)				
CH <sub>3</sub> CH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
	[70693-47-9] TSCA EC 274-767-7 HMIS: 2-2-	-1-X	10g	50g			
	SIP6720.0						
CI	PENTYLTRICHLOROSILANE	209.59	171-2		1.142	1.4456	
X	AMYLTRICHLOROSILANE	Flashpoint: 3					
sH <sub>11</sub> -Si-Cl	C <sub>5</sub> H <sub>11</sub> Cl <sub>3</sub> Si Mixed isomers		t: 0.35 cal/g/°				
CI	See also SII6453.5	Viscosity: 1.	•				
201	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pro	•					
	[107-72-2] TSCA EC 203-515-0 HMIS: 3-3-		25g				
	SIP6720.2		3				
OC. H		004.44	05.074.0		0.005	4.4050	
OC <sub>2</sub> H <sub>5</sub>	PENTYLTRIETHOXYSILANE	234.41	95-6 / 1.3		0.895	1.4059	
I <sub>11</sub> -Si-OC <sub>3</sub> H <sub>3</sub>	AMYLTRIETHOXYSILANE	Flashpoint: 6	oo°C (154°F)				
OC5Hs	C <sub>11</sub> H <sub>26</sub> O <sub>3</sub> Si Mixed isomers						
- THE THE P. S	Viscosity: 2.1 cSt						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	4. V	2-				
	[2761-24-2] TSCA EC 220-429-9 HMIS: 2-2-	-1-X	25g				
	SIP6720.5						
QC <sub>2</sub> H <sub>5</sub>	PERFLUORODODECYL-1H,1H,2H,2H-TRIETHOXY-	710-810	157-198 / 1.5	(70-85)			
	SILANE - PERFLUOROTETRADECYL-1H,1H,2H,2H-TRIETHOXY			(10 00)			
ден <sub>2</sub> ен <sub>2</sub> — si — ос <sub>2</sub> н <sub>3</sub>	Contains ~ 5% SIH5841.2, balance higher homologs						
OC <sub>2</sub> H <sub>4</sub>	For the preparation of low surface energy substrates						
	See also SIH5840.25						
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
	HMIS: 2-1-	1-Y	5g				
	DIVIS: 7-1-	1-A	ou				

	name				MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
OC2H1	C <sub>20</sub> H <sub>19</sub> F <sub>17</sub> O <sub>3</sub> Si	CTYL)PHENYL	TRIETHOXYSILANE		658.50 Flashpoint: >1	101-3 / 1 10°C (>230°F)		1.448	
oc:ni	Contact angl 1. Kondo, Y.	le treated glass	s surface, water: 115 te, 2004, 53, 143 tracts slowly with mois	sture/water		1.0=			
	SIP6720.72			HMIS: 3-1-1-X		1.0g			
ocu	[PERFLUORO(PO		NEOXY)]METHOXY- , 20% in fluorinated h		4,000-8,000			1.5	
οιατιστιστησιματή το του συστασιατή οι οι Οι οι	HYDROLYT	IC SENSITIVIT	ΓY: 7: reacts slowly w			40			
	[870998-79-0] SIP6720.8	TSCA		HMIS: 2-0-1-X		10g			
-(CH <sub>2</sub> ) <sub>2</sub> S -Ct	PHENETHYLDIIS C <sub>14</sub> H <sub>23</sub> CISi		Mixed $\alpha$ -, $\beta$ -isome		254.86	105-9 / 0.3		0.970	
CHCHOL	[151613-24-0]	TSCA	: reacts rapidly with mos	sture, water, protic solvent HMIS: 3-2-1-X	S	5g			
	SIP6721.0								
Cu, Cu,	PHENETHYLDIM C <sub>10</sub> H <sub>15</sub> CISi See also SIF		ROSILANE Contains α-, β-iso	mers	198.77 Flashpoint: 70	56 / 0.2 °C (158°F)		0.999	1.5185
ar-si-a				sture, water, protic solvent	S	50			
City	[17146-08-6] SIP6721.2	TSCA	EC 241-207-8	HMIS: 3-2-1-X		50g			
Die CHI		ETHYL(DIME <sup>-</sup>	THYLAMINO)SILANE Contains 10-15%		207.39	109 / 2		0.890	1.4946
CH <sub>2</sub> -Si-NOCH <sub>2</sub>		SENSITIVITY: 7 TSCA	: reacts slowly with mois	sture/water HMIS: 3-2-1-X		100			
City	[181231-68-5] SIP6721.5	TOCA		TIMIO. 3-2-1-X		10g			
<b></b>	PHENETHYLMET METHYL(PHENETH		SILANE		219.19 Flashpoint: 80	99 / 6 °C (176°F)		1.127	1.5120
Ċη <sub>2</sub> -Şi-Ci <sub>1</sub> ,	C <sub>9</sub> H <sub>12</sub> Cl <sub>2</sub> Si HYDROLYTIC [772-65-6]	SENSITIVITY: 8	Contains α-, β-ison reacts rapidly with mois EC 212-253-6	mers sture, water, protic solvent HMIS: 3-2-1-X	s	25g	100g		
7)	SIP6722.0								
as P	PHENETHYLTRIC C <sub>8</sub> H <sub>9</sub> Cl <sub>3</sub> Si	CHLOROSILAI	NE Contains α-, β-iso	mers	239.60 Flashpoint: 91 TOXICITY: or	93-6 / 3 °C (196°F) ral rat, LD50: 2,830 mg/kg		1.240	1.5185
CH <sub>2</sub> -SI-CI	[940-41-0]	SENSITIVITY: 8 TSCA	EC 213-371-0	sture, water, protic solvent HMIS: 3-2-1-X		25g	100g		
$\Diamond$	SIP6722.6 PHENETHYLTRIN	METHOXYSII	ΔNF		226.35	95-6 / 2		1.037	1.4753
Си, оси,	C <sub>11</sub> H <sub>18</sub> O <sub>3</sub> Si Component	in optical coati	Contains α-, β-ison ng resins	mers -1 molecular sieves. <sup>1</sup>	Flashpoint: 10			1.037	1.4700
CH <sub>2</sub> -Si=OCH <sub>4</sub>			ter. Res. <b>2008</b> , 47-50						
осн	HYDROLYTIC		: reacts slowly with mois	sture/water					
осн	[49539-88-0]	SENSITIVITY: 7				25g	100g		2kg
ÇII, Şi-Ci	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi	TSCA ENYLDIMETH	Ec 256-363-2  YLCHLOROSILANE, Contains other iso	sture/water HMIS: 3-1-1-X 95% mers	262.81	25g 102-6 / 1	100g	1.11 <sup>25</sup>	2kg 1.5603 <sup>25</sup>
çu,	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, M	TSCA  ENYLDIMETHY  for low-temper  M. ASLE Trans.	reacts slowly with mois EC 256-363-2 CCHLOROSILANE, Contains other iso actions 1972, 18, 31.	sture/water HMIS: 3-1-1-X 95% emers is. <sup>1</sup>			100g	1.11 <sup>25</sup>	
ÇII, Şi-Ci	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, M HYDROLYTIC	TSCA  ENYLDIMETHY  for low-temper  M. ASLE Trans.	reacts slowly with mois EC 256-363-2 CCHLOROSILANE, Contains other iso actions 1972, 18, 31.	sture/water HMIS: 3-1-1-X 95% mers s.1			100g	1.11 <sup>25</sup>	
ÇII, Şi-Ci	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, M HYDROLYTIC [41318-68-7] SIP6723.2 3-PHENOXYPRO	TSCA  ENYLDIMETHY for low-temper  1. ASLE Trans. SENSITIVITY: 8	reacts slowly with mois EC 256-363-2 CCHLOROSILANE, Contains other iso actions 1972, 18, 31.	sture/water HMIS: 3-1-1-X  95% mers is.¹  sture, water, protic solvent		102-6 / 1	100g	1.11 25	
CH3	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, M HYDROLYTIC [41318-68-7] SIP6723.2 3-PHENOXYPRO C <sub>11</sub> H <sub>17</sub> CIOSi	TSCA  ENYLDIMETHY for low-temper  A. ASLE Trans. SENSITIVITY: 8  DPYLDIMETHY	Creacts slowly with mois EC 256-363-2  YLCHLOROSILANE, Contains other iso rature lubricating fluid actions 1972, 18, 31.  Creacts rapidly with mois YLCHLOROSILANE	sture/water HMIS: 3-1-1-X  95% mers is.¹  sture, water, protic solvent	s 228.78	102-6 / 1 5g	100g		1.5603 <sup>25</sup>
CH3	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, M HYDROLYTIC [41318-68-7] SIP6723.2 3-PHENOXYPRO C <sub>11</sub> H <sub>17</sub> CIOSi HYDROLYTIC [69733-73-9] SIP6723.25 3-PHENOXYPRO	TSCA  ENYLDIMETHY for low-temper A. ASLE Trans. SENSITIVITY: 8  PYLDIMETHY SENSITIVITY: 8	Creacts slowly with mois EC 256-363-2  YLCHLOROSILANE, Contains other iso rature lubricating fluid actions 1972, 18, 31.  Creacts rapidly with mois YLCHLOROSILANE	sture/water HMIS: 3-1-1-X 95% mers s.¹ sture, water, protic solvent HMIS: 3-2-1-X	s 228.78	102-6 / 1 5g 90-2 / 0.25			1.5603 <sup>25</sup>
CH <sup>3</sup>	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, M HYDROLYTIC [41318-68-7] SIP6723.2 3-PHENOXYPRO C <sub>11</sub> H <sub>17</sub> CIOSi HYDROLYTIC [69733-73-9] SIP6723.25 3-PHENOXYPRO C <sub>10</sub> H <sub>14</sub> Cl <sub>2</sub> OSi HYDROLYTIC [28229-56-3]	TSCA  ENYLDIMETHY  for low-temper  A. ASLE Trans. SENSITIVITY: 8  DPYLDIMETHY  SENSITIVITY: 8	Creacts slowly with mois EC 256-363-2  YLCHLOROSILANE, Contains other iso rature lubricating fluid actions 1972, 18, 31.  Creacts rapidly with mois reacts rapidly with mois reacts rapidly with mois creacts rapidly with mois contains a contain a conta	sture/water HMIS: 3-1-1-X 95% mers s.¹ sture, water, protic solvent HMIS: 3-2-1-X	228.78 s	5g 90-2 / 0.25 25g		1.034	1.5603 <sup>25</sup>
CH3	[49539-88-0] SIP6723.0 m-PHENOXYPHE C <sub>14</sub> H <sub>15</sub> CIOSi End-capper 1. Gardos, N HYDROLYTIC [41318-68-7] SIP6723.2 3-PHENOXYPRO C <sub>11</sub> H <sub>17</sub> CIOSi HYDROLYTIC [69733-73-9] SIP6723.25 3-PHENOXYPRO C <sub>10</sub> H <sub>14</sub> Cl <sub>2</sub> OSi HYDROLYTIC [28229-56-3] SIP6723.3 3-PHENOXYPRO C <sub>9</sub> H <sub>11</sub> Cl <sub>3</sub> OSi	TSCA  ENYLDIMETHY for low-temper  M. ASLE Trans. SENSITIVITY: 8  DPYLDIMETHY SENSITIVITY: 8  DPYLMETHYLE SENSITIVITY: 8	E reacts slowly with mois EC 256-363-2  YLCHLOROSILANE, Contains other iso atture lubricating fluid actions 1972, 18, 31.  E reacts rapidly with mois reacts rapidly with mois creacts rapidly with mois reacts rapidly with mois ROSILANE	sture/water HMIS: 3-1-1-X  95% smers s.¹  sture, water, protic solvent HMIS: 3-2-1-X  sture, water, protic solvent HMIS: 3-2-1-X	228.78 s 249.21 s 269.63 Flashpoint: >1	102-6 / 1  5g  90-2 / 0.25  25g  110 / 1		1.034	1.5603 <sup>25</sup>

	name
	CID6702 4
7	SIP6723.4  11-PHENOXYUNDECYLTRICHLOROSILANE
	C <sub>17</sub> H <sub>27</sub> Cl <sub>3</sub> OSi Forms SAMs that orient pentadecene
S CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,
	[526204-46-6] H
5400	SIP6724.7
CH <sub>1</sub>	4-PHENYLBUTYLDIMETHYLCHLOROSILANE
(CH5) Si-Cl	$C_{12}H_{19}CISi$
CH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,
	[32328-67-9] H
C1	SIP6724.8
- CILVEL-CIL	4-PHENYLBUTYLMETHYLDICHLOROSILANE
Constant con	C <sub>11</sub> H <sub>16</sub> Cl <sub>2</sub> Si
- Kel	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, [17776-69-1]
	<u> </u>
	SIP6724.9
-	4-PHENYLBUTYLTRICHLOROSILANE
(CH <sub>2</sub> ) <sub>4</sub> Si -Cl	C <sub>10</sub> H <sub>13</sub> Cl <sub>3</sub> Si Employed as bonded phase in HPLC separation of a
- CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,
	[17886-88-3] TSCA-L H
754741 7520	SIP6726.0
2/ tn, 8	PHENYLDIMETHYLACETOXYSILANE
Si-o-ccH2	C <sub>10</sub> H <sub>14</sub> O <sub>2</sub> Si
CH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/
5. T. T. T.	[17887-60-4] TSCA EC 241-836-8 H
	SIP6728.0
	PHENYLDIMETHYLCHLOROSILANE
92410	C <sub>8</sub> H <sub>11</sub> CISi
∠ CH <sup>3</sup>	Viscosity: 1.4 cSt
))—și-ci	Vapor pressure, 25°: 1 mm
CH <sub>2</sub>	Forms cuprate. <sup>1</sup>
Varchill	1. Fleming, I. and Terrett, N. K. Tetrahedron Lett. 196
	F&F: Vol. 7, p 133; Vol. 8, p 196; Vol. 11, p 209; Vol.
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, [768-33-2] TSCA EC 212-193-0 H
	SIP6728.4 PHENYLDIMETHYLETHOXYSILANE
≥ cH³	PHENYLDIMETHYLETHOXYSILANE C <sub>10</sub> H <sub>16</sub> OSi
) - Si-OC <sub>2</sub> H <sub>5</sub>	Viscosity: 1.3 cSt
СН	Dipole moment: 1.34
	Antiepileptic activity in petit mal syndrome
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/
	[1825-58-7] TSCA EC 217-366-4 H
327	SIP6729.5
ÇH <sub>1</sub>	12-PHENYLDODECYLDIMETHYLCHLOROSILANE
-(CHOLT-SI-CI	$C_{20}H_{35}CISi$
CHi	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/
	Н
$\overline{\sim}$	SIP6730.0
( ))	PHENYLETHYLDICHLOROSILANE
C ,cı	C <sub>8</sub> H <sub>10</sub> Cl <sub>2</sub> Si
Si	Vapor pressure, 100°: 13 mm
C2H5 CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, [1125-27-5] TSCA EC 214-407-8 H
0.00	1
7 9	SIP6736.4
>-(CH <sub>3</sub> ) <sub>*</sub> -S -C	6-PHENYLHEXYLTRICHLOROSILANE
=/	C <sub>12</sub> H <sub>17</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,
3500	[18035-33-1] HYDROLY IIC SENSITIVITY: 8: reacts rapidly with moisture,
	SIP6736.8
))	
N(CH <sub>D2</sub>	PHENYLMETHYLBIS(DIMETHYLAMINO)SILANE C <sub>11</sub> H <sub>20</sub> N <sub>2</sub> Si
SI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,
N(CH <sub>3</sub> ) <sub>2</sub>	[33567-83-8] H

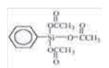
name				MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>	
SIP6723.4 11-PHENOXYUI	NDECYLTRICI	HLOROSILANE		381.85	166-7 / 0.3		1.089 25		
C <sub>17</sub> H <sub>27</sub> Cl <sub>3</sub> OSi Forms SAM	Ms that orient p	pentadecene							
	IC SENSITIVITY:	8: reacts rapidly with moi	sture, water, protic solvents	s	E				
[526204-46-6] SIP6724.7			HMIS: 3-1-1-X		5g				
4-PHENYLBUTY C <sub>12</sub> H <sub>19</sub> ClSi		CHLOROSILANE	oturo water pretio colventi		85-7 / 0.6 110°C (>230°F)		0.964 25	1.4979 <sup>25</sup>	
[32328-67-9]	IC SENSITIVITY:	8: reacts rapidly with mol	sture, water, protic solvents HMIS: 3-1-1-X	S	25q				
SIP6724.8					- 3				
$C_{11}H_{16}CI_2Si$		CHLOROSILANE			105-9 / 1.5 110°C (>230°F)		1.09 25		
[17776-69-1]	IC SENSITIVITY:	8: reacts rapidly with moi	sture, water, protic solvents HMIS: 3-1-1-X	s	25g				
SIP6724.9 4-PHENYLBUTY C <sub>10</sub> H <sub>13</sub> Cl <sub>3</sub> Si	YLTRICHLORO	OSILANE		267.66	82 / 0.4		1.192	1.512	
	as bonded pha	ase in HPLC separation	n of aromatics	riasripoliti. >	110°C (>230°F)				
		·	sture, water, protic solvents HMIS: 3-1-1-X	s	25g	100g			
SIP6726.0									
PHENYLDIMET C <sub>10</sub> H <sub>14</sub> O <sub>2</sub> Si	HYLACETOX	/SILANE		194.30 Flashpoint: 72	127-9 / 44		1.006	1.4907	
	IC SENSITIVITY:	7: reacts slowly with mois	sture/water	riasripoliti. 12	2 (102 F)				
[17887-60-4]	TSCA	EC 241-836-8	HMIS: 2-2-1-X		25g				
SIP6728.0 PHENYLDIMET	HYLCHLORO:	SILANE		170.71	192-3		1.032	1.5082	
C <sub>8</sub> H <sub>11</sub> CISi	1.4.00+			Flashpoint: 6					C
Viscosity: 1 Vapor pres	sure, 25°: 1 m	m		ΔHvap: 11.4	kcai/IIIole				COMMERCIAL
Forms cup									ERC
F&F: Vol. 7	7, p 133; Vol. 8	N. K. <i>Tetrahedron Let</i> , p 196; Vol. 11, p 209;	Vol. 12, p 210.						ZIAL
[768-33-2]	TSCA	8: reacts rapidly with moi EC 212-193-0	sture, water, protic solvents HMIS: 3-2-1-X	S	25g	100g		2kg	
SIP6728.4	100/1	20212 100 0	10.0 2 1 7		09	9		ZNG	
PHENYLDIMET	HYLETHOXYS	SILANE		180.32	93 / 25		0.926	1.4799	
C <sub>10</sub> H <sub>16</sub> OSi	1 2 -0+			Flashpoint: 6					
Viscosity: 1 Dipole mor				TOXICITY: 0	ral rat, LD50: 2,460 mg/kg				
		tit mal syndrome							
		7: reacts slowly with mois			40	FO			
[1825-58-7] SIP6729.5	TSCA	EC 217-366-4	ΠΙΝΙΙ <b>5. 2-2-1-</b> Λ		10g	50g			
	DECYLDIMET	HYLCHLOROSILANE		339.03	172-4 / 0.25		0.921	1.487	
$C_{20}H_{35}CISi$									
HYDROLYTI	IC SENSITIVITY:	7: reacts slowly with mois	sture/water HMIS: 3-2-1-X		5g				
SIP6730.0			11W10. 3-2-1-X		υg				
PHENYLETHYL	.DICHLOROSI	LANE		205.16	225-6		1.184	1.5321	
C <sub>8</sub> H <sub>10</sub> Cl <sub>2</sub> Si				Flashpoint: 92					
	sure, 100°: 13		sture, water, protic solvents	ΔHvap: 11.9	kcal/mole				
[1125-27-5]	TSCA	EC 214-407-8	HMIS: 3-2-1-X	3	25g				
SIP6736.4									
6-PHENYLHEXY C <sub>12</sub> H <sub>17</sub> Cl <sub>3</sub> Si				295.71	95 / 0.1		1.144	1.5065	
	IC SENSITIVITY:	8: reacts rapidly with moi	sture, water, protic solvents HMIS: 3-1-1-X	s	5g				
[18035-33-1] SIP6736.8			TIMIO. 0-1-1-A		√y				
	YLBIS(DIMETH	HYLAMINO)SILANE		208.38 Flashpoint: 78	108-9 / 11 8°C (172°F)			1.4982	
	IC SENSITIVITY:	8: reacts rapidly with moi	sture, water, protic solvents	-	5 5 (112 1 )				
[33567-83-8]			HMIS: 3-2-1-X		10g				















name				MW	bp/mm (	mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$	
SIP6738.0										
PHENYLMETH	YLDICHLOROS	SILANE		191.13	205-6	(-53)		1.187	1.5180	
C <sub>7</sub> H <sub>8</sub> Cl <sub>2</sub> Si				Flashpoint: 82	, ,					
	ssure, 82.5°: 13	mm			or mouse, LD50: 300					
	1.5 kcal/mole	n 247: Vol. 12 n 221		Autoignition to	emperature: >400°C	,				
		I, p 247; Vol. 12, p 231 8: reacts rapidly with mois		nts						
[149-74-6]	TSCA	EC 205-746-2	HMIS: 3-2-1-X	1113	25g		500g			
SIP6738.5					9		5			
	METHYLDICHLO	OROSILYL)BUTANE		247.24	87-9 / 1			1.1	1.512	
C <sub>11</sub> H <sub>16</sub> Cl <sub>2</sub> Si		0.100.2.2,20.7.1.2			110°C (>230°F)			***		
HYDROLYT	IC SENSITIVITY:	8: reacts rapidly with mois	sture, water, protic solve		,					
			HMIS: 3-2-1-X		25g					
SIP6739.0										
PHENYLMETH	YLDIETHOXYS	ILANE		210.35	117-8 / 31			0.963	1.4690	
C <sub>11</sub> H <sub>18</sub> O <sub>2</sub> Si				Flashpoint: 89	9°C (192°F)					
•	ment: 1.32									
		7: reacts slowly with mois EC 212-275-6	ture/water HMIS: 2-2-1-X		250		100g			
[775-56-4]	TSCA	EG 212-275-0	ΠΙΝΙΙΟ. 2-2-1-Λ		25g		Tuug			
SIP6740.0	VI DIMETLION	CH AND		400.00	400.000			0.0004	4.4004	
PHENYLMETH C <sub>9</sub> H <sub>14</sub> O <sub>2</sub> Si	I LUIME I HOX I	SILAINE		182.29	199-200			0.9934	1.4694	
	20°: 1.65 cSt			Flashpoint: 70	ral rat, LD50: 892 m	n/kn				
		t systems, increasing i	nterface flexibility, U\		Tai Tai, 2000. 002 III	9/119				
		7: reacts slowly with mois		,						
[3027-21-2]	TSCA	EC 221-192-4	HMIS: 3-2-1-X		25g		250g		2kg	
SIP6743.0										
(3-PHENYLPRO	OPYL)DIMETH	YLCHLOROSILANE		212.78	75 / 0.5			0.963		
C <sub>11</sub> H <sub>17</sub> CISi				Flashpoint: 10	03°C (217°F)					
See also S										
	TSCA	8: reacts rapidly with mois EC 241-208-3	sture, water, protic solve HMIS: 3-1-1-X	nts	5g		50g			
[17146-09-7]	ISCA	EG 24 1-200-3	HIVIIO. 3-1-1-A		- Jy		oug			
SIP6744.0		DIGUI ODGGU ANE		000.04	00.044			1.086 <sup>25</sup>	4 5000 25	
$C_{10}H_{14}CI_2Si$	JPYL)IMETHYL	DICHLOROSILANE		233.21	96-8 / 4			1.086	1.5090 <sup>25</sup>	
	IC SENSITIVITY	8: reacts rapidly with mois	sture water protic solve	nts						
[17776-66-8]	TSCA		HMIS: 3-2-1-X		25g					
SIP6790.0										
PHENYLTRIAC	ETOXYSILANE	tech-95		282.32	144-6 / 2	(36-7)		1.1939	1.4708	
C <sub>12</sub> H <sub>14</sub> O <sub>6</sub> Si		•		Flashpoint: 10		( /				
HYDROLYT	IC SENSITIVITY:	7: reacts slowly with mois	ture/water	•						
[18042-54-1]	TSCA	EC 241-952-9	HMIS: 3-1-1-X		25g		100g			
SIP6810.0										
PHENYLTRICH	LOROSILANE			211.55	201	(-33)		1.324	1.5247	
C <sub>6</sub> H <sub>5</sub> Cl <sub>3</sub> Si				Flashpoint: 9		,,				
Viscosity:		200		Critical tempe	ral rat, LD50: 2,340	mg/kg				
	ssure, 75°: 10 m ment: 2.41	1111		ΔHvap: 11.4						
	nsion: 27.9 mN	I/m		Specific heat:						
					thermal expansion:	1.2 x 10 <sup>-3</sup>				
HYDROLYT	IC SENSITIVITY:	8: reacts rapidly with mois	sture, water, protic solve			10				
[98-13-5]	TSCA	EC 202-640-8	HMIS: 3-2-1-X		25g		2kg		18kg	
SIP6813.0									<u> </u>	
1-PHENYL-1-TI	RICHLOROSIL	YLBUTANE		267.65	78-80 / 0.8			1.201	1.518	
C <sub>10</sub> H <sub>13</sub> Cl <sub>3</sub> Si					110°C (>230°F)			•		
	IC SENSITIVITY:	8: reacts rapidly with mois	sture, water, protic solve	-						
			HMIS: 3-2-1-X		10g					

	€ <sup>2</sup> H³O,	OC <sub>2</sub> H <sub>5</sub>	
	Сн,о	OCH <sub>3</sub>	
20140	n,c. n₁2 c=N-	сн,	>
	сн₃сн₃- ,сн₂сн₂	CH <sub>3</sub> -Si-OCH <sub>3</sub> -CH <sub>3</sub> -CH <sub>3</sub> -Si-CH <sub>3</sub>	
	i <sub>3</sub> CH <sub>2</sub> CII <sub>3</sub>	ден, Сі	
	I₃CH₂CI CH₂CH₃	CI  CI  OC <sub>2</sub> H <sub>5</sub> —SI—OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub>	

name	MW	bp/mm (m	p)	D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>	
SIP6821.0						
PHENYLTRIETHOXYSILANE	240.37	112-3 / 10		0.996	1.4718	
C <sub>12</sub> H <sub>20</sub> O <sub>3</sub> Si Viscosity, 25°: 1.7 cSt	Flashpoint: 96	5°C (205°F) ral rat, LD50: 2,830 mg	/ka			
Vapor pressure, 75°: 1 mm		emperature: 265°C	/kg			
Dipole moment: 1.85 debye	Ŭ	thermal expansion: 0.9	9 x 10 <sup>-3</sup>			2
Dielectric constant: 4.12	Surface tension	on: 28 mN/m				OM)
Electron donor component of polyolefin polymerization catalyst con	nplexes					COMMERCIAL
Improves photoresist adhesion to silicon nitride  Effective treatment for organic-grafted clays. <sup>1</sup>						QA
Phenylates allyl benzoates. <sup>2</sup>						7
1. Canrado, K. et al. <i>Chem. Mater.</i> <b>2001</b> , <i>13</i> , 3766.						
2. Correia, R. and DeShong, P. <i>J. Org Chem.</i> <b>2001</b> , 66, 7159.						
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
[780-69-8] TSCA EC 212-305-8 HMIS: 2-1-1-X		100g	2kg		17kg	
SIP6822.0	400.00			4.004	4.470.4	
PHENYLTRIMETHOXYSILANE $C_9H_{14}O_3Si$	198.29		(-25)	1.064	1.4734	
Viscosity, 25°: 2.1 cSt	Flashpoint: 86 TOXICITY: iv	n mouse, LD50: 180 m	a/ka			
Vapor pressure, 108°: 20 mm	Dielectric con		5 5			
Dipole moment: 1.77						
Intermediate for high temperature silicone resins  Hydrophobic additive to other silanes with excellent thermal stabilty	,					COMMERCIAL
Cross couples with aryl halides. <sup>1</sup>	,					ME
Phenylates heteroaromatic carboxamides. <sup>2</sup>						RCL.
Directly couples w/ 1° alkyl bromides and iodides. <sup>3</sup>						£.
1. Mowery, M. E. and DeShong, P. <i>J. Org. Chem.</i> <b>1999</b> , <i>64</i> , 1684.						
2. Lam, P. Y. S. et al. Tetrahedron Lett. 2001, 42, 2427.						
3. Young, JY. and Fu, G. C. <i>J. Am. Chem. Soc.</i> <b>2003</b> , <i>125</i> , 5616.						
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [2996-92-1] TSCA EC 221-066-9 HMIS: 3-2-1-X		100g	2kg		18kg	
SIP6826.5		1009	Zitg		TONG	
PHENYLTRIS(METHYLETHYLKETOXIMINO)SILANE	363.53	60-5 / 3		0.995		
C <sub>18</sub> H <sub>29</sub> N <sub>3</sub> O <sub>3</sub> Si 95%		61°C (>142°F)				
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water			0.50			
[34036-80-1] TSCA HMIS: 3-2-1-X		50g	250g			
SIP6910.0 n-PROPYLDIMETHYLCHLOROSILANE	136.70	113-4		0.8726	1.4138	
C <sub>5</sub> H <sub>13</sub> CISi	Flashpoint: 10			0.0720	1.4100	
HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solv	-					
[17477-29-1] TSCA EC 241-492-9 HMIS: 3-4-1-X		25g	100g			
SIP6911.0	400.00				4 0007 25	
n-PROPYLDIMETHYLMETHOXYSILANE $C_6H_{16}OSi$	132.28	94-6		0.787	1.3927 25	
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water						
[18182-14-4] HMIS: 3-3-1-X		10g				
SIP6912.0						_
n-PROPYLMETHYLDICHLOROSILANE	157.11	125		1.027	1.425	
C <sub>4</sub> H <sub>10</sub> Cl <sub>2</sub> Si	Flashpoint: 27	7°C (81°F)				
Viscosity, 20°: 0.8 cSt HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solvers.	vents					
[4518-94-9] TSCA EC 224-843-0 HMIS: 3-3-1-X		25g	100g			
SIP6914.0			-			
n-PROPYLMETHYLDIMETHOXYSILANE	148.28	126		0.8689	1.3931	
$C_6H_{16}O_2Si$						
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [18173-73-4] HMIS: 3-3-1-X		25g				
[18173-73-4] HMIS: 3-3-1-X SIP6915.0		20 <b>y</b>				
n-PROPYLTRICHLOROSILANE	177.53	123-4		1.185	1.4290	Co
C <sub>3</sub> H <sub>7</sub> Cl <sub>3</sub> Si	Flashpoint: 35			1.100	1.1200	WW
Vapor pressure, 16°: 10 mm	ΔHvap: 8.7 k					COMMERCIAL
HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic solv	vents	05~	0.51			TAL
[141-57-1] TSCA EC 205-489-6 HMIS: 3-3-1-X		25g	2.5kg			
						S
SIP6917.0	206.36	170.00		0.8016	1 3056	
SIP6917.0 n-PROPYLTRIETHOXYSILANE	206.36 Flashpoint: 57	179-80 7°C (135°F)		0.8916	1.3956	мм
SIP6917.0 n-PROPYLTRIETHOXYSILANE C <sub>9</sub> H <sub>22</sub> O <sub>3</sub> Si Architectural masonry water repellant	206.36 Flashpoint: 57			0.8916	1.3956	OMMERO
SIP6917.0 n-PROPYLTRIETHOXYSILANE C <sub>9</sub> H <sub>22</sub> O <sub>3</sub> Si			2kg	0.8916	1.3956	COMMERCIAL

	name	MW	bp/mm (mp)	D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
CH <sub>3</sub> CH <sub>2</sub> CH <sub>3</sub>	SIP6917.2 PROPYLTRIETHOXYSILANE, oligomeric hydrolysate Viscosity: 25-40 cSt			1.03	1.4243
$C_2H_4$ $OC_2H_5$ $OC_2H_1$ $OC_2H_1$	Reactive hydrophobic surface treatment with reduced vola HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [314270-00-3] TSCA HMIS: 2		100g		
осн <sub>а</sub> сн <sub>а</sub>	SIP6918.0 n-PROPYLTRIMETHOXYSILANE C <sub>e</sub> H <sub>16</sub> O <sub>3</sub> Si	164.27 Flashpoin	142 it: 34°C (93°F)	0.932 <sup>2</sup>	<sup>5</sup> 1.3880
осн,	yc of treated surface: 28.5 mN/m Hydrophobic surface treatment HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water		/: oral rat, LD50: 7,420 mg/kg		
	[1067-25-0] TSCA EC 213-926-7 HMIS: 3 SIS6952.0 SILICLAD® OCTADECYL FUNCTIONAL SILANE		25g	2kg 0.88	16kg
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>12</sub> —S <sub>1</sub> —0—	20% in t-AMYL ALCOHOL and DIACETONE ALCOHOL Amber liquid	Coefficier Surface re	tt: 25°C (77°F)  It of friction of treated glass surfacesistivity of treated surface: 1.2 and ted glass surface: 31 mN/m		
\bar{\bar{\bar{\bar{\bar{\bar{\bar{	For application information see Performance Products Bro Reduces blood protein adsorption. <sup>1</sup> Anti-stiction coating for polysilicon. <sup>2</sup>	•	leu glass sunace. 31 mwm		
	<ol> <li>Arkles, B. et al. In Silanes Surfaces &amp; Interfaces; Leyde</li> <li>Almanza-Workman, A. et al. J. Electrochem. Soc. 2002, HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water</li> </ol>	149, H6.			
	[39443-39-5] TSCA HMIS: 2 SIS6984.0	2-3-1-X	100g	1.5kg	15kg
H <sub>3</sub> С−Şi−О <sup>*</sup> Na*	SODIUM METHYLSILICONATE, 30% in water CH <sub>6</sub> NaO <sub>3</sub> Si Viscosity: 10 cSt.	116.12 pH: 13.0		1.24	
OH	Forms economical water-repellent coatings HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions  [16589-43-8] TSCA EC 240-648-3 HMIS: 3	3-0-0-X	500g	2kg	20kg
ÇI ;	SIT7093.0 TETRADECYLTRICHLOROSILANE	331.83	155-6 / 3	1.00	1.4575
CH <sub>3</sub> (CH <sub>2</sub> ) <sub>13</sub> -\$i-CI CI	C <sub>14</sub> H <sub>22</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, [18402-22-7] TSCA HMIS: 3	protic solvents	25g		
OC2H5 OC2H5 H3C-Si-O-Si-CH3	SIT7095.0 1,1,3,3-TETRAETHOXY-1,3-DIMETHYLDISILOXANE, 95% $C_{10}H_{2e}O_{5}Si_{2}$	282.48 Flashpoin	205 t: 58°C (136°F)	0.953	1.3912
OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [18001-60-0] EC 241-915-7 HMIS: 3	3-2-1-X	25g		
CH <sub>3</sub> CH <sub>3</sub> C <sub>2</sub> H <sub>3</sub> O - Si - OC <sub>2</sub> H <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	SIT7534.0 1,1,3,3-TETRAMETHYL-1,3-DIETHOXYDISILOXANE C <sub>B</sub> H <sub>22</sub> O <sub>3</sub> Si <sub>2</sub> Viscosity: 1.0 cSt	222.43 Flashpoin	161 (-134 t: 43°C (109°F)	0.8788	1.3880
city city	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water           [18420-09-2]         TSCA         EC 242-298-7         HMIS: 2           SIT7753.0         HMIS: 2         EC 242-298-7         HMIS: 2	2-2-0-X	25g	100g	
O O	C <sub>28</sub> H <sub>27</sub> NSi <sub>2</sub> Deactivates glass capillary columns by persilylation. <sup>1</sup>	409.68 Flashpoin	218-220 / 1.5 (91) at: >110°C (>230°F)		
	Grob, K. et al. High Resol. Chrom. & Col Chrom. 1980, HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [7453-26-1] TSCA EC 231-227-5 HMIS: 2		5g	25g	
H <sub>3</sub> C CH <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> CHC—Si—CI	SIT7906.0 THEXYLDIMETHYLCHLOROSILANE t-HEXYLDIMETHYLCHLOROSILANE	178.78 Flashpoin	55-6 / 10 (14-1 t: 51°C (124°F)	-	1.4490
нас сна сна	C <sub>e</sub> H <sub>19</sub> CISi F&F: Vol. 13, p 74. HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, [67373-56-2] HMIS: 3	•	25g	100g	
H <sub>3</sub> C CH <sub>2</sub> CI CHC—Si-CI	SIT7906.6 THEXYLTRICHLOROSILANE	219.61	70-2 / 15	1009	
H₃C cu, ci	C <sub>e</sub> H <sub>13</sub> Cl <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, [18151-53-6] HMIS: 3	•	10g		
H <sub>2</sub> C - Si - Cl	SIT8030.0 p-TOLYLDIMETHYLCHLOROSILANE C <sub>9</sub> H <sub>15</sub> CISi		215-7 it: 67°C (153°F)	1.007 <sup>2</sup>	<sup>5</sup> 1.5055
3443	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water,  [35239-30-6] TSCA EC 252-456-7 HMIS: 3		5g		
п,с 1-сп,	SIT8035.0 p-TOLYLMETHYLDICHLOROSILANE C <sub>8</sub> H <sub>10</sub> Cl <sub>2</sub> Si HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water,		161-5 / 7 it: 80°C (176°F)	1.1609	1.5330
1.000	[25898-37-7] TSCA HMIS: 3		25g		

						GCICSI, II
	name	MW	bp/mm (r	np)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{_{\scriptscriptstyle 20}}$
	SIT8040.0					
CI CI	p-TOLYLTRICHLOROSILANE	225.58	218-20		1.28	1.5224 <sup>25</sup>
sc-( )-si-ci	C <sub>7</sub> H <sub>7</sub> Cl₃Si	Flashpoint:	92°C (198°F)			
CI	γc of treated surface: 34 mN/m					
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s [701-35-9] TSCA EC 211-854-0 HMIS: 3-2-1-X	solvents	250	100g		
	[701-35-9] TSCA EC 211-854-0 HMIS: 3-2-1-X SIT8042.0		25g	1009		
	p-TOLYLTRIMETHOXYSILANE	212.32	75-8 / 8		1.033	1.4726 <sup>25</sup>
OCH,	$C_{10}H_{16}O_3Si$		94°C (201°F)		1.033	1.4720
c Si-ocii	yc of treated surface: 34 mN/m					
OCH <sub>3</sub>	Charge control surface treatment for electrostatic copier particles. <sup>1</sup>					
	1. Yamazaki, H. Jpn. Kokai JP 06027719 A2, 1994.					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [17873-01-7] HMIS: 3-1-1-X		10g	50g		
	[17873-01-7] HMIS: 3-1-1-X SIT8045.0		109	509		
CH <sub>3</sub>	TRIACONTYLDIMETHYLCHLOROSILANE, blend	515.42		(60-82)		
H <sub>2</sub> (CH <sub>2</sub> ) <sub>28</sub> CH <sub>2</sub> -Si - Ci	$C_{32}H_{67}CISi$ 80% $C_{30}$ and higher, 20% $C_{22}$ - $C_{28}$	010.12		(00 02)		
CH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s	solvents				
	[70851-52-4] TSCA EC 274-938-6 HMIS: 3-1-0-X		25g	100g		
	SIT8048.0					
ÇI	TRIACONTYLTRICHLOROSILANE, blend	556.26		(60-82)		
I <sub>3</sub> (CH <sub>2</sub> ) <sub>28</sub> CH <sub>2</sub> -Si - Cl	C <sub>30</sub> H <sub>61</sub> Cl <sub>3</sub> Si 80% C <sub>30</sub> and higher, 20% C <sub>22</sub> -C <sub>28</sub> Employed in bonded phases for HPLC of carotenes					
CI	See also SIH5917.0 HEXACOSYLTRICHLOROSILANE; SIT8162.0	13-(TRICHLOR	OSILYLMETHYL)HEP	TACOSANE		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s	solvents				
	[70851-48-8] TSCA EC 274-933-9 HMIS: 3-1-1-X		25g	100g		
	SIT8162.0					
	13-(TRICHLOROSILYLMETHYL)HEPTACOSANE, 95%	528.21	215 / 0.01	(20-35)	0.946	
	2-DODECYLHEXADECYLTRICHLOROSILANE  C <sub>28</sub> H <sub>57</sub> Cl <sub>3</sub> Si Contains isomers					
~~~~	5281 15/10/301					
and the same of th	Forms bonded phases for HPLC applications					
c c	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s	solvents				
	[194242-99-4] TSCA-L HMIS: 3-1-1-X		10g			
CH <sub>2</sub> (CU <sub>2</sub> ) <sub>5</sub> -	SIT8162.4	250.00	440.450.40.0		0.005	
CHCH <sub>2</sub> Si(Cl) <sub>1</sub>	7-(TRICHLOROSILYLMETHYL)PENTADECANE, tech-95 2-HEXYLDECYLTRICHLOROSILANE	359.88	146-152 / 0.2		0.985	
снасная	C <sub>16</sub> H <sub>33</sub> Cl <sub>3</sub> Si Contains isomers					
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s	solvents				
	HMIS: 3-2-1-X		10g			
	SIT8170.0					
	(TRIDECAFLUORO-1,1,2,2-TETRAHYDROOCTYL)-	440.70	189-91		1.473	1.3453
	DIMETHYLCHLOROSILANE PERFLUOROOCTYL-1H,1H,2H,2H-DIMETHYLCHLOROSILANE	Flashpoint:	52°C (126°F)			
	C <sub>10</sub> H <sub>10</sub> CIF <sub>13</sub> Si Packaged over copper powder					
CH	Employed in column chromatography whore low protein retentivity is	s required.1				
CF_CF_CF_CF_CF_CF_CH_CH_Si-	·					
CH						
	1. Xindu, G. et al. J. Chromatogr. 1983, 269, 96.					
	2. Curran, D. J. Org. Chem. 1997, 62, 6714.					
	3. Ogawa, M. et al. <i>Chem. Mater.</i> <b>1998</b> , <i>10</i> , 3787. For branched fluorinated alkylsilane see SIB1706.0					
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s	solvents				
	[102488-47-1] HMIS: 3-2-1-X	iorvonto	10g	50g		
	SIT8172.0		- J	<u> </u>		
	(TRIDECAFLUORO-1,1,2,2-TETRAHYDROOCTYL)-	461.12	189-90		1.550 <sup>25</sup>	1.3500
çı	METHYLDICHLOROSILANE	Flashpoint:	51°C (124°F)			
F <sub>2</sub> CF <sub>2</sub> CF <sub>2</sub> CF <sub>2</sub> CF <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> Si-CH						
CI	Vapor pressure, 76°: 12 mm	volvente				
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s [73609-36-6] EC 277-551-0 HMIS: 3-2-1-X	OUVEIRS	10g	50g		
	SIT8174.0		109	oog		
Carr	(TRIDECAFLUORO-1,1,2,2-TETRAHYDROOCTYL)-	481.55	84-5 / 17		1.639	1.3521
CF;CF;CF;CF;CF;CH;CH;Si~Cl	TRICHLOROSILANE		54°C (129°F)			
b	$C_8H_4Cl_3F_{13}Si \hspace{1cm} \hbox{Packaged over copper powder}$	•				
	Lowers the coefficient of friction of silicon substrates. <sup>1</sup>					
	1. DePalma, V. et al. <i>Langmuir</i> <b>1989</b> , <i>5</i> , 868.	-b				
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s [78560-45-9] TSCA EC 278-947-6 HMIS: 3-2-1-X	soivents	10g	50g		
			iuu	30u		

	name				MW	bp/mm (m	p)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{\scriptscriptstyle 20}$	
реді, Уқтұсуұсуқтұруқпіқпіді —осді, Осді,	TRIETHOXYSILA C <sub>14</sub> H <sub>19</sub> F <sub>13</sub> O <sub>3</sub> Si	NE	RAHYDROOCTYL)		Viscosity: 3 ΔHvap: 66.		(<-38)	1.351	1.3436	
	Automotive side wir to provide self-clear		l with fluoroalkylsilane	es .	See also SIN					
	HYDROLYTIC [51851-37-7]	SENSITIVITY: 7	7: reacts slowly with m EC 257-473-3	noisture/water HMIS: 2-2-1-X		10g	50g			
	SIT8176.0	100/1	LO 201-410-0	THINIO. Z-Z-T-X		109	009			
осп, татататататапапап-осп, осп,	TRIMETHOXYSIL C <sub>11</sub> H <sub>13</sub> F <sub>13</sub> O <sub>3</sub> Si	ANE	RAHYDROOCTYL) 7: reacts slowly with m		468.29	60-2 / 0.5		1.44	1.3322	
	[85857-16-5]	TSCA-L	EC 288-657-1	HMIS: 3-1-1-X		10g	50g			
arararararar ararararararararar	$C_{16}H_7CI_3F_{26}Si$	ROHEXYL)DEC	DECAFLUORO-2- YLTRICHLOROSIL Contains ~ 5% is w surface tension S	omers	827.63	110-4 / 0.8		1.709	1.338	
	HYDROLYTIC	SENSITIVITY: 7	7: reacts slowly with m			1.0~				
	SIT8364.0			HMIS: 3-1-1-X		1.0g				
CF <sub>3</sub> CH <sub>2</sub> CH <sub>2</sub> - Si - CI CH <sub>3</sub>	(3,3,3-TRIFLUOR C₅H₁₀CIF₃Si	,	METHYLCHLOROSI	ILANE noisture, water, protic so	190.67	118		1.113	1.3727	
5,500)	[1481-41-0]	TSCA	EC 216-039-3	HMIS: 3-4-1-X		5g	25g			
сғ₃сн₂сн₂ —şi — сн₃	SIT8369.0 (3,3,3-TRIFLUOR $C_4H_7Cl_2F_3Si$ $\Delta Hcomb: 2$	,	THYLDICHLOROSI	ILANE		121-2 15°C (59°F) ipr mouse, 254 mg/kg		1.2611	1.3850	
CI			3: reacts rapidly with r	moisture, water, protic so		ipi modoo, zo i mg/kg				
100	[675-62-7]	TSCA	EC 211-623-4	HMIS: 3-4-1-X		10g	50g			
CF <sub>3</sub> CH <sub>2</sub> CH <sub>2</sub> — Si — CI		SENSITIVITY: 8	3: reacts rapidly with r	noisture, water, protic sc		113-4 15°C (59°F)		1.395	1.385	
	[592-09-6]	TSCA	EC 209-744-2	HMIS: 3-4-1-X		10g	50g			
осн <sub>3</sub> сғ <sub>3</sub> сн <sub>2</sub> сн <sub>2</sub> —şі—осн <sub>3</sub>	$C_6H_{13}F_3O_3Si$	OPROPYL)TRI	METHOXYSILANE		218.25 Flashpoint:	144 38°C (100°F)		1.137	1.3546	
оси,	Forms cataly 1. Cirminna,	tic gels for aero R. et al. <i>Org. B</i>		, 4, 2637.	vith tetrapropyla	ammonium perrhenate.	1			
	[429-60-7]	TSCA	EC 207-059-3	HMIS: 3-3-1-X		5g	25g		2.5kg	
	SIT8510.0 TRIMETHYLCHLOUTHCS C <sub>3</sub> H <sub>9</sub> CISi Viscosity: 0 Vapor press		m		TOXICITY: Autoignition	57.6 -27°C (-17°F) ihl mouse, LDLo: 500 r temperature: 395° perature: 224.6°	(-57.7) ng/m³/10M	0.8580	1.3885	
сн- сн <sub>3</sub> сн <sub>3</sub>	Surface tens Dipole mom	ure, 50°: 591 m sion: 17.8 mN/n ent: 2.09 t: 0.42 cal/g/°			ΔHcomb: -	ssure: 31.6 atm 714 kcal/mole 4.5 kcal/mole 6 kcal/mole				
	Most econor		nsion: 1.2 x 10 <sup>-3</sup> lly used silylation re- ement. <sup>1</sup>	agent						
	Enhances e	hylene glycol k	of tBOC-protected a etalization reaction. chlorohydrin esters f	3						
	Reviewed a: 1. Snider, B. 2. Chen, B. 3. Chan, T. I 4. Eras, J. e 5. Volochnul F&F: Vol. 1,	s water scaveng B. and Hawrylu C. et al. <i>J. Org.</i> H. et al. <i>Synthes</i> t al. <i>J. Org. Che</i> c, D. M. et al. Sj p 1232; Vol. 2,	ger in reactions of calk, N. A. Org. Synth Chem. 1999, 64, 92 sis 1983, 203. em. 2002, I, 8631. synthesis 2009, 3718 p 435; Vol.3, p 310;	arbonyl compounds. <sup>5</sup> . <b>2000</b> , 2, 635. 294. 0. Vol. 4, p 32, p 537; Vo		. 6, p 25; Vol. 7, p 66; V				
	Vol. 17, p	79; Vol. 19, p 37	74; Vol. 20, p 348, p	I. 12, p 126; Vol. 13, p 380, p 404; Vol.21, p noisture, water, protic sc	453.	175; Vol. 15, p 89; Vol.	ιο, μ σο;			
	[75-77-4]	TSCA	EC 200-900-5	HMIS: 3-4-2-X		25g	750g		3kg	

name		MW	bp/mm (r	mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
SIT8515.0 TRIMETHYLETHOXYSILANE		118 25	75-6	(-83)		0.7573	1.3742
				(-03)		0.7575	1.0742
			· ,				
·		2ap. 00.0	TOOL THOU				
_	oisture/water						
			25g		1.5kg		14kg
· · · · ·					nong		ring
		104.00	<b>57.0</b>			0.7500	4 2670
						0.7560	1.3678
		Flashpoint: -1	11°C (12°F)				
· · · · · · · · · · · · · · · · · · ·							
·							
_	<b>0,</b> 595, 87.						
[1825-61-2] TSCA EC 217-369-0	HMIS: 3-4-1-X		25g		100g		1.5kg
SIT8572.6							
TRIMETHYLSILOXYTRICHLOROSILANE		223.63	128			1.1405	1.4032
$C_3H_9CI_3OSi_2$		Flashpoint: 1	6°C (61°F)				
HYDROLYTIC SENSITIVITY: 8: reacts rapidly with n	noisture, water, protic so	lvents					
[2750-45-0]	HMIS: 3-4-1-X		25g				
SIT8582.7							
TRIMETHYLSILOXYTRIETHOXYSILANE		252.46	62 / 9			0.897	1.3866 <sup>25</sup>
	oisture/water						
			25g				
-							
		175.25	EE 6 / 17	( 11)		0 050 22	1.432 22
				(-11)		0.000	1.432
	oisturolwator	riasripoliti. 3	0 C (00 F)				
			10a		50a		
<u> </u>	11W10. 0-0-1-X		109		Jug		
		447.00	0-11-			0.00=0	4 4405
	-	417.32	85 / 0.6			0.9056	1.4135
0 0	)4°.1						
		lvents					
	HMIS: 3-2-1-X		10g				
SIU9050.0							
UNDECYLTRICHLOROSILANE		289.75	155-60 / 15			1.02	
C <sub>11</sub> H <sub>23</sub> Cl <sub>3</sub> Si		Flashpoint: 1					
Employed in SAMS as a spacer molecule for fu	nctionally tipped silane	es	•				
HYDROLYTIC SENSITIVITY: 8: reacts rapidly with n	noisture, water, protic so	lvents					
[18052-07-8]	HMIS: 3-1-1-X		25g				
	SIT8515.0  TRIMETHYLETHOXYSILANE  ETHOXYTRIMETHYLS/ILANE  C <sub>5</sub> H <sub>14</sub> OSi Vapor pressure, 25°: 111 mm Dipole moment: 1.2 Anti-structuring additive for silicone rubber HYDROLYTIC SENSITIVITY: 7: reacts slowly with m  [1825-62-3] TSCA EC 217-370-6  SIT8566.0  TRIMETHYLMETHOXYSILANE  C <sub>4</sub> H <sub>12</sub> OSi Dipole moment: 1.18 debye AHcomb: 908 kcal/mole Undergoes α-lithiation w/ tert-butyllithium.¹ 1. Bates, T.F. et al. <i>J. Organometal. Chem.</i> 2000 F&F: Vol. 14, p 119. HYDROLYTIC SENSITIVITY: 7: reacts slowly with m  [1825-61-2] TSCA EC 217-369-0  SIT8572.6  TRIMETHYLSILOXYTRICHLOROSILANE C <sub>3</sub> H <sub>2</sub> C <sub>3</sub> OSi <sub>2</sub> HYDROLYTIC SENSITIVITY: 8: reacts rapidly with m  [2750-45-0]  SIT8582.7  TRIMETHYLSILOXYTRIETHOXYSILANE C <sub>3</sub> H <sub>2</sub> C <sub>4</sub> O <sub>4</sub> Si <sub>2</sub> HYDROLYTIC SENSITIVITY: 7: reacts slowly with m  [17861-35-7]  SIT8712.0  TRIS(DIMETHYLAMINO)METHYLSILANE C <sub>7</sub> H <sub>2</sub> :N <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with m  [3768-57-8] TSCA EC 223-199-8  SIT8719.5  [TRIS(TRIMETHYLSILOXY)SILYLETHYL]DIMETHYL CHLOROSILANE C <sub>13</sub> H <sub>37</sub> ClO <sub>3</sub> Si <sub>5</sub> Forms highly hydrophobic monolayers Candidate for self-cleaning surfaces Water contact angle: advancing = receding = 10 1. McCarthy, T. et al. Langmuir 1999, 15, 7328. HYDROLYTIC SENSITIVITY: 8: reacts rapidly with m  [225794-57-0]  SIU9050.0  UNDECYLTRICHLOROSILANE C <sub>11</sub> H <sub>23</sub> Cl <sub>3</sub> Si Employed in SAMS as a spacer molecule for full HYDROLYTIC SENSITIVITY: 8: reacts rapidly with m	SIT8515.0  TRIMETHYLETHOXYSILANE  C3H12OSi  Vapor pressure, 25°: 1111 mm  Dipole moment: 1.2  Anti-structuring additive for silicone rubber  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [1825-62-3]  TSCA  EC 217-370-6  HMIS: 2-4-1-X  SIT8566.0  TRIMETHYLMETHOXYSILANE  C4H12OSi  Dipole moment: 1.18 debye  AHcomb: 908 kcal/mole  Undergoes a-lithiation w/ tert-butyllithium.¹  1. Bates, T.F. et al. <i>J. Organometal. Chem.</i> 2000, 595, 87.  F&F: Vol. 14, p 119.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [1825-61-2]  TSCA  EC 217-369-0  HMIS: 3-4-1-X  SIT8572.6  TRIMETHYLSILOXYTRICHLOROSILANE  C3H3C13OSi2  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so  [2750-45-0]  HMIS: 3-4-1-X  SIT8582.7  TRIMETHYLSILOXYTRIETHOXYSILANE  C3H2c1-3C51  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [17861-35-7]  HMIS: 2-2-1-X  SIT8712.0  TRIS(DIMETHYLAMINO)METHYLSILANE  C-H3RSG  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [3768-57-8]  TSCA  EC 223-199-8  HMIS: 3-3-1-X  SIT8719-5  [TRIS(TRIMETHYLSILOXY)SILYLETHYL]DIMETHYL-  CHLOROSILANE  C13H37C10-3Si3  Forms highly hydrophobic monolayers  Candidate for self-cleaning surfaces  Water contact angle: advancing = receding = 104°.¹  1. McCarthy, T. et al. Langmuir 1999, 15, 7328.  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so  [225794-57-0]  HMIS: 3-2-1-X  SIU9050.0  UNDECYLTRICHLOROSILANE  C1+H2sClsii  Employed in SAMS as a spacer molecule for functionally tipped silane HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so  [225794-57-0]  HMIS: 3-2-1-X	SIT8515.0   TRIMETHYLETHOXYSILANE	SIT8515.0   TRIMETHYLETHOXYSILANE   118.25   75-6   Flashpoint: 27°C (-17°F)   C <sub>2</sub> H <sub>14</sub> OSi   Critical temperature: 233°   Alcomb: 970.4 kcal/mole   Altomb: 908 kcal/mole   Altomb: 908 kcal/mole   Altomb: 908 kcal/mole   Altomb: 908 kcal/mole   Undergoes a-lithiation w/ tert-butyllithium.¹   1. Bates, T.F. et al. J. Organometal. Chem. 2000, 595, 87.   FaF: Vol. 14, p.119.   HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water   [1825-61-2]   TSCA	SIT8515.0   TRIMETHYLETHOXYSILANE	STR8515.0	SIT8615.0   TRIMETHYLETHOXYSILANE



# **Hydrophobic Dipodal Silanes**

Dipodal Surface Bonding

	name		MW	bp/mm (m	p)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
CIMe <sub>2</sub> SiCH <sub>2</sub> CH <sub>2</sub> SiMe <sub>2</sub> C	SIB1030.0 BIS[2-(CHLORODIMETHYLSILYL)ETHYL]BENZENE C <sub>14</sub> H <sub>24</sub> Cl <sub>2</sub> Si <sub>2</sub> Mixed isomers Intermediate for silahydrocarbon polymers HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo	pisture, water, protic solv	·	116-7 / 0.2 87°C (369°F)		1.02	
	[74129-20-7] TSCA SIB1042.0 1,2-BIS(CHLORODIMETHYLSILYL)ETHANE TETRAMETHYLDICHLORODISILETHYLENE	HMIS: 3-1-1-X	215.27 Flashpoint: 4	50g 198-9	(36-9)		
C(CH <sub>3)2</sub> SiCH <sub>2</sub> CH <sub>2</sub> Si(CH <sub>3</sub> ) <sub>2</sub> Cl	$ \begin{array}{c} C_6H_{16}Cl_2Si_2 \\ \text{Reagent for protection of primary amines, includi} \\ \text{1. Djuric, S. et al. } \textit{Tetrahedron Lett. } \textbf{1981, } 22, 17. \\ HYDROLYTIC SENSITIVITY: 8: reacts rapidly with model of the product of the prod$	87.	·	25g	100g		
G(CH <sub>3</sub> ) <sub>2</sub> Si(CH <sub>2</sub> ) <sub>6</sub> Si(CH <sub>3</sub> ) <sub>2</sub> Cl	$\begin{split} & \text{SIB1046.0} \\ & \text{1,6-BIS(CHLORODIMETHYLSILYL)} \\ & \text{HEXANE, 95\%} \\ & \text{C}_{\text{10}} \\ & \text{H}_{\text{24}} \\ & \text{Cl}_{\text{2}} \\ & HYDROLYTIC SENSITIVITY: 8: reacts rapidly with model of the second $	oisture, water, protic solv		113-6 / 3 50°C (302°F)		0.961	1.4538
C(CH <sub>3</sub> ) <sub>2</sub> Si(CH <sub>2</sub> ) <sub>8</sub> Si(CH <sub>3</sub> ) <sub>2</sub> Cl	$\begin{tabular}{ll} $[14799-66-7]$ \\ SIB1048.0 \\ 1.8-BIS(CHLORODIMETHYLSILYL)OCTANE, 95\% \\ C_{12}H_{28}Cl_2Si_2 \\ Intermediate for silahydrocarbon polymers \\ \end{tabular}$	HMIS: 3-1-1-X	299.43 Flashpoint: 1	25g 106-7 / 0.4 80°C (356°F)		0.946	1.4540
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo [5089-28-1] EC 225-804-0 SIB1048.2	oisture, water, protic solv HMIS: 3-1-1-X	rents	25g	100g		
CIT-Si CH <sub>1</sub> CH <sub>2</sub> CH <sub>2</sub> CH <sub>3</sub>	1,3-BIS(CHLORODIMETHYLSILYL)PROPANE  C <sub>7</sub> H <sub>18</sub> Cl <sub>2</sub> Si <sub>2</sub> Forms cyclic derivatives of polyalkyleneoxides su	itable for enjerie con	229.30	94/19		1.0244	1.4647
ci-si cits	1. Zundel, T. et al. <i>Macromol.</i> <b>1998</b> , <i>31</i> , 2724. HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo			5g			
ÇI CH <sub>2</sub> ŞİCH <sub>2</sub> CH <sub>2</sub> ŞİCH <sub>3</sub> CI CI	SIB1614.0  1,2-BIS(METHYLDICHLOROSILYL)ETHANE 2,2,5,5-TETRACHLORO-2,5-DISILAHEXANE C <sub>4</sub> H <sub>10</sub> Cl <sub>4</sub> Si <sub>2</sub> Dipodal coupling agent HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo	sisturo water pretio colo	256.11 Flashpoint: 9	208-210 4°C (201°F)	(31-3)	1.2628	1.4760
	[3353-69-3] TSCA EC 222-123-0	HMIS: 3-2-1-X	ents	25g	100g		
сн, сн,	SIB1615.0  1,2-BIS(METHYLDIETHOXYSILYL)ETHANE  C <sub>12</sub> H <sub>30</sub> O <sub>4</sub> Si <sub>2</sub> 1,2-BIS(METHYLDIETHOXYSILYL)ETHANE	intura huatar	294.54 Flashpoint: >	80 / 1.5 65°C (>150°F)		0.92	1.4170
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo [18043-74-8] EC 241-953-4 SIB1630.0	HMIS: 2-2-1-X		25g			
сн <sub>з</sub> місн <sub>2</sub> сн <sub>2</sub> місн <sub>3</sub>	1,2-BIS(METHYLDIFLUOROSILYL)ETHANE C <sub>4</sub> H <sub>10</sub> F <sub>4</sub> Si <sub>2</sub>	:	190.29	114		1.118	
>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo [170381-99-4] SIB1808.0	HMIS: 3-3-1-X	rents	10g			
}	1,2-BIS(TRICHLOROSILYL)DECANE $C_{10}H_{20}CI_6Si_2$	of pU	409.16	114 / 1		1.2496	1.4754
SiCl <sub>1</sub>	Bonded phase for HPLC stable over wide range HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo [620987-03-3] TSCA-L		rents	25g			
Cl <sub>3</sub> Si(CH <sub>2</sub> ) <sub>10</sub> SiCl <sub>3</sub>	SIB1809.0 1,10-BIS(TRICHLOROSILYL)DECANE, tech-95 $C_{10}H_{20}Cl_{9}Si_{2}$		409.16	156-9 / 1			
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo [52217-62-6]	isture/water HMIS: 3-2-1-X		10g			

	name	MW	bp/mm (n	np)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
CLEVELEVELEVEL	SIB1811.5 1,8-BIS(TRICHLOROSILYLETHYL)HEXADECAFLUORO-	725.06	142-4 / 0.6	(69-70)		
H <sub>2</sub> CH <sub>2</sub> CH <sub>3</sub> CH <sub>2</sub> ICI <sub>4</sub> SiCI <sub>4</sub>	OCTANE  C <sub>12</sub> H <sub>8</sub> Cl <sub>8</sub> F <sub>16</sub> Si <sub>2</sub> Forms hydrolysis-resistant oleophobic coatings					
7.11	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [445303-83-3] HMIS: 3-1-1-X		1.0g			
Çı Çı Cı—şi(CH₂)₅şi−Cı	SIB1812.0 1,6-BIS(TRICHLOROSILYL)HEXANE $C_6H_{12}Cl_6Si_2$	353.05 Flashpoint: 7	148-50 / 10 75°C (167°F)		1.327	1.4759
ćı ćı	Forms mesoporous sol-gel structures HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s  [13083-94-8] TSCA EC 235-994-7 HMIS: 3-2-1-X	solvents	10g	50g		
çı çı	SIB1813.0 BIS(TRICHLOROSILYL)METHANE CH <sub>2</sub> Cl <sub>6</sub> Si <sub>2</sub>	282.90	183		1.5567	1.4740
CI CI	Nucleus for star polymers and dendrimers HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s  [4142-85-2] TSCA-L HMIS: 3-2-1-X	solvents	5g	25g		
}	SIB1813.7  1,2-BIS(TRICHLOROSILYL)OCTADECANE  C <sub>18</sub> H <sub>36</sub> Cl <sub>6</sub> Si <sub>2</sub>	520.36	186-9 / 0.2		1.103	
E Nich	Hydrolysis resistant dipodal bonded phase for high acidity aqueous HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protics HMIS: 3-1-1-X		10g			
$\begin{matrix} C_1 & C_1 \\ C_1 & C_1 \\ C_1 & C_1 \end{matrix}$	SIB1814.0  1,8-BIS(TRICHLOROSILYL)OCTANE  C <sub>8</sub> H <sub>16</sub> Cl <sub>6</sub> Si <sub>2</sub>	381.10 Flashpoint: ′	140 / 1 115°C (239°F)		1.22	1.4757
CI CI	Forms mesoporous sol-gel structures HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s  [52217-53-5] EC 257-748-8 HMIS: 3-1-1-X	solvents	25g	100g		
C1 1—\$1CH2CH2CH2\$1—C1	SIB1815.0 1,3-BIS(TRICHLOROSILYL)PROPANE C <sub>3</sub> H <sub>6</sub> Cl <sub>6</sub> Si <sub>2</sub>	310.97	115-7 / 4	(29-30)	1.4394	1.4732
(ci sci	Forms mesoporous sol-gel structures HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic s  [18171-50-1] HMIS: 3-2-1-X	solvents	10g			
Cl <sub>3</sub> Si(CH <sub>2</sub> ) <sub>11</sub> O	SIB1815.4 BIS(TRICHLOROSILYLUNDECYL) ETHER C <sub>22</sub> H <sub>44</sub> Cl <sub>6</sub> OSi <sub>2</sub>	593.48				
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protics HMIS: 3-1-1-X	solvents	5g			
-H49 / OC-H4	SIB1816.6 1,4-BIS(TRIETHOXYSILYL)BENZENE C <sub>18</sub> H <sub>34</sub> O <sub>6</sub> Si <sub>2</sub>	402.64	130-2 / 0.4		1.015	1.4549
слі'ю ослі' слі'ю ослі'	1. Inagaki, S. et al. <i>Nature</i> <b>2002</b> , <i>416</i> , 304. 2. Wang, W. et al. <i>Chem. Mater.</i> <b>2003</b> , <i>15</i> , 4886.					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [2615-18-1] HMIS: 2-2-1-X		5g	25g		
	SIB1817.0		-9			
	BIS(TRIETHOXYSILYL)ETHANE  HEXAETHOXYDISILETHYLENE, BSE  C <sub>14</sub> H <sub>34</sub> O <sub>6</sub> Si <sub>2</sub> Vapor pressure, 150°: 10mm		96 / 0.3 107°C (225°F) oral rat, LD50: 161 mg	(-33) /kg	0.957	1.4052
OC <sub>2</sub> H <sub>3</sub> OC <sub>2</sub> H <sub>3</sub> OC <sub>2</sub> H <sub>4</sub> OC <sub>2</sub> H <sub>3</sub> OC <sub>2</sub> H <sub>4</sub> OC <sub>2</sub> H <sub>3</sub>	Additive to silane coupling agents formulations that enhances hydro Employed in corrosion resistant coatings/primers for steel and alum Sol-gels of α,ω-bis(trimethoxysilyl)alkanes reported. <sup>3</sup>	lytic stability	o komolo			
7.7	Component in evaporation-induced self-assembly of mesoporous st Forms mesoporous, derivatizeable molecular sieves. 5,6	ructures.4				
	<ol> <li>Van Ooij, W. et al. J. Adhes. Sci. Tech. 1997, 11, 29.</li> <li>Van Ooij, W. et al. Chemtech 1999, 28, 3302.</li> <li>Loy, D. A. et al. J. Am. Chem. Soc. 1999, 121, 5413.</li> <li>Lu Y et al. J. Am. Chem. Soc. 2000, 122, 5258.</li> </ol>					
	<ol> <li>Lu, Y. et al. J. Am. Chem. Soc. 2000, 122, 5258.</li> <li>Molde, B. et al. Chem. Mater. 1999, 11, 3302.</li> <li>Cho, E. et al. Chem Mater. 2004, 16, 270.</li> <li>See also SIB1821.0, SIT8185.8</li> </ol>					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [16068-37-4] TSCA EC 240-212-2 HMIS: 3-1-1-X		25g	100g		2kg

COMMERCIAL

	name			MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
	•	SILYL)METHANE		340.56	114-5 / 3.5		0.9741	1.4098
OE: OE:		HOXY-3,7-DIOXA-4,6-DIS	SILANONANE					
EtO-ŞiCH <sub>2</sub> Şi -OEt	C <sub>13</sub> H <sub>32</sub> O <sub>6</sub> Si <sub>2</sub> Intermediate	e for sol-gel coatings. I	hybrid inorganic-organic polymers					
OEt OEt		ylene-bridged mesopo						
		I. et al. Chem. Mater. 2						
			ts slowly with moisture/water		_			
	[18418-72-9]	TSCA-L	HMIS: 3-2-1-X		5g	25g		
	SIB1824.0	OVVEILVI VOCTANE		438.76	470 E / 0 7E		0.026	1 4240
	C <sub>20</sub> H <sub>46</sub> O <sub>6</sub> Si <sub>2</sub>	DXYSILYL)OCTANE			172-5 / 0.75 oral rat, LD50: 16,400 mg/kg		0.926	1.4240
15O)2Si(CH2)8Si(OC2H3)		n sol-gel synthesis of n	nesoporous structures		orar rai, 2200. 10, 100 mg/ng			
		α,ω-bis(trialkoxysilyl)al	lkanes reported.1					
1	-	et al. J. Am. Chem. S						
\$	HYDROLY 110 [52217-60-4]	C SENSITIVITY: 7: react TSCA	ts slowly with moisture/water HMIS: 2-1-1-X		25g	100g		
	SIB1829.0	100A	11W10. 2-1-1-X		209	1009		
7		HOXYSILYL)DECANE		382.65	130-2 / 0.4		0.984	1.4303
>	C <sub>16</sub> H <sub>38</sub> O <sub>6</sub> Si <sub>2</sub>	, -,		= 2				- <del></del>
>		odal silane; employed						
SIGOCIIA			ts slowly with moisture/water		05	400		
2007-11797	[832079-33-1]	TSCA-L	HMIS: 3-2-1-X		25g	100g		
	SIB1830.0	JOYVOII VI JETHANE		270.42	102.475		1 069	1 4001
	1,2-BIS(TRIMETE C <sub>8</sub> H <sub>22</sub> O <sub>6</sub> Si <sub>2</sub>	HOXYSILYL)ETHANE		270.43 Flashpoint: 6	103-4 / 5 65°C (149°F)		1.068	1.4091
осн, осн,	36.122363.2	CAUTION: INHAL	_ATION HAZARD		inh rat, LC50: 2.4 ppm			
OCH, OCH,		AIR TRANSPORT		Vapor pressi	ure, 20°: 0.08mm			
outing today		-	/er printed circuit boards.1					
	See also SI	, J. U.S. Patent 5,073, R1817 0	450, 1991.					
			ts slowly with moisture/water					
	[18406-41-2]		242-285-6 HMIS: 4-2-1-X		25g	100g		
0) <sub>2</sub> Si(CH <sub>2</sub> ) <sub>2</sub>	SIB1831.0							
	BIS(TRIMETHOX	(YSILYLETHYL)BENZ		374.58	148-50 / 0.1		1.08	1.4734
	C <sub>16</sub> H <sub>30</sub> O <sub>6</sub> Si <sub>2</sub>		ed isomers	Flashpoint: 1	193°C (379°F)			
CH26SKOCH35	-	refractive index coatin	gs is slowly with moisture/water					
(41/2004/14/10)	[58298-01-4]	TSCA	HMIS: 2-1-0-X		10g	50g		
	SIB1832.0				•			
THE STATE OF THE S		HOXYSILYL)HEXANE		326.54	161 / 2		1.014	1.4213
OCII, OCII, II,O—Si(CII,),Si = OCII,	$C_{12}H_{30}O_6Si_2$			Flashpoint: 9	95°C (203°F)			
OCH <sub>3</sub> OCH <sub>3</sub>		α,ω-bis(trimethoxysily	,					
Och Och	•	et al. J. Am. Chem. So	oc. <b>1999,</b> <i>121</i> , 5413.  s slowly with moisture/water					
	[87135-01-1]	C SENSITIVITY: 7: Teact	HMIS: 3-2-1-X		10g	50g		
	SIB1832.2							
,octi,		HOXYSILYLMETHYL)	BENZENE	346.53	124-5 / 0.05		1.097	1.47 25
SI-CH, SI-OCH, OCH,	C <sub>14</sub> H <sub>26</sub> O <sub>6</sub> Si <sub>2</sub>	_,			<del>-</del>			
		erent films on metal sul						
		C SENSITIVITY: 7: react	ts slowly with moisture/water		10~			
(CH <sub>2</sub> ) <sub>4</sub> SicOCH <sub>2</sub> ) <sub>1</sub>	[193358-40-6]		HMIS: 3-1-1-X		10g			
A THE PARTY OF THE	SIB1833.4	HOXYSILYLPROPYL)I	RENZENE	402.64				
	C <sub>18</sub> H <sub>34</sub> O <sub>6</sub> Si <sub>2</sub>	IOATOILILI AUFTLI	₩ - 1 1 4 L	70∠.U <del>1</del>				
		C SENSITIVITY: 7: react	ts slowly with moisture/water					
(сирыосил			HMIS: 3-2-1-X		5g			
	SIC2265.5							
170		HYLSILYL)-6-[2-(CHL	ORODIMETHYL-	309.43			1.03	1.4863
His A CHERSI-C	SILYL)ETHYL]BIO C <sub>13</sub> H <sub>26</sub> Cl <sub>2</sub> Si <sub>2</sub>		ture of 1 and 2 regio isomers, exo a	and endo				
TV CIII	Forms polyn		5 01 1 and 2 10910 150111615, 6XU d	a ondo				
1000			ts slowly with moisture/water					
	[220527-24-2]		HMIS: 3-2-1-X		25g			
	SIT8185.8							
QC2H1 QC2H1		ILYL)-2-(DIETHOXYM	ETHYLSILYL)-	324.56	100 / 0.5		0.946	1.4112
-SiCH <sub>2</sub> CH <sub>2</sub> Si -OC <sub>2</sub> H <sub>3</sub>	ETHANE				102°C (216°F)			
OC2H1 OC2H1	C <sub>13</sub> H <sub>32</sub> O <sub>5</sub> Si Dipodal silar	ne: forms abrasion-res	sistant sol-gel coatings	TOXICITY: (	oral rat, LD50: >500 mg/kg			
			ane adhesion promotion systems					
			ts slowly with moisture/water					
	[18418-54-7]	TSCA	HMIS: 3-1-1-X		25g	100g		2kg

## Polymeric Hydrophobic Silanes

Polymeric Surface Bonding

	name	MW	bp/mm (mp)	$D_4^{20}$ $n_D^{20}$
$\begin{array}{ccc} \mathrm{CH_2} & \mathrm{CH_2} \\ \mathrm{CH} & \mathrm{II} \\ \mathrm{CH} & \mathrm{CH} \\ -\mathrm{CH_2CHCH_2CHCH_2CH} -\\ \mathrm{CH_2CH_2Si(OC_2H_5)_3} \end{array}$	Polybutadiene SSP-055 TRIETHOXYSILYL MODIFIED POLY-1,2-BUTADIENE, 50% in toluene Viscosity: 100-200 cSt Coupling agent for EPDM resins	3,500-4,500		0.90
	[72905-90-9] TSCA HMIS: 2-4	-1-X store <5°	100g	2kg
$\begin{array}{ccc} \operatorname{CH}_2 & \operatorname{CH}_2 \\ \operatorname{II} & \operatorname{II} \\ \operatorname{CH} & \operatorname{CH} \\ -\operatorname{CH}_2\operatorname{CHCH}_2\operatorname{CHCH}_2\operatorname{CH} - \\ \operatorname{CH}_2\operatorname{CH}_2\operatorname{Si}(\operatorname{OC}_2\operatorname{H}_5)_3 \end{array}$	SSP-056 TRIETHOXYSILYL MODIFIED POLY-1,2-BUTADIENE, 50% in volatile silicone Viscosity: 100-200 cSt Primer coating for silicone rubbers	3,500-4,500		0.93
	[72905-90-9] TSCA HMIS: 2-3-	-1-X store <5°	100g	
CH2 CH2 CH CH CH CH CH CH2CHCH2CHCH2CH CH2CH2Si(OC2H3)2 CH3	SSP-058 DIETHOXYMETHYLSILYL MODIFIED POLY-1,2-BUTA- DIENE, 50% in toluene Viscosity: 75-150 cSt Water tree resistant additive for crosslinkable HDPE cable cla HMIS: 2-4	•	100g	0.90
	SSP-255 (30-35% TRIETHOXYSILYLETHYL)ETHYLENE- (35-40% 1,4-BUTADIENE)-(25-30% STYRENE) terpolymer, 50% in Viscosity: 20-30 cSt	4,500-5,500 n toluene		
CH <sub>2</sub> CH <sub>2</sub> Si(OC <sub>2</sub> H <sub>5</sub> ) <sub>3</sub>	HMIS: 2-3-	-1-X	100g	

### **Reactive Polydimethylsiloxane Oligomers**

#### **Chlorine Terminated PolyDimethylsiloxanes**

<b>Chlorine Tern</b>	ninated PolyDimeth	CAS: [67923-13-1] TSCA			
Code	Viscosity	Molecular Weight	Specific Gravity	Price/100g	Price/1kg
DMS-K05	3 - 6	425-600	1.00		
DMS-K13	20-50	2000-4000	0.99		
DMS-K26	500-800	15,000-20,000	0.99		

#### **Dimethylamino Terminated PolyDimethylsiloxanes**

Dimethylamino	Terminated PolyDi	CAS: [67762-92-9] TSCA			
Code	Viscosity	Molecular Weight	Specific Gravity	Price/100g	
DMS-N05	3 - 8	450-600	0.93		

#### **Ethoxy Terminated PolyDimethylsiloxanes**

Code	Viscosity	Molecular Weight	Specific Gravity	Price/100g	Price/1kg
DMS-XE11	5-10	800-900	0.94		

#### Methoxy Terminated PolyDimethylsiloxanes

Code	Viscosity	Molecular Weight	Specific Gravity	Price/100g	Price/1kg
DMS-XM11	5-12	900-1000	0.94		

#### Silanol Terminated PolyDimethylsiloxanes

CAS:	[70131	-67-8]	TSCA
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CAS: [70851-25-1] TSCA

CAS: [68951-97-3] TSCA

		Molecular			Specific	Refractive	<u> </u>		
Code	Viscosity	Weight	% (OH)	(OH) - Eq/kg	Gravity	Index	Price/100g	Price/3kg	Price/16kg
DMS-S12	16-32	400-700	4.5-7.5	2.3-3.5	0.95	1.401			
DMS-S14	35-45	700-1500	3.0-4.0	1.7-2.3	0.96	1.402			
DMS-S15	45-85	2000-3500	0.9-1.2	0.53-0.70	0.96	1.402			

# Hydrophilic Silane Properties Polar - Non-hydrogen Bonding

	name	MW	bp/mm (mp	)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
	SIB1660.0					
сн, ксн,уюсн,снолисн,уюст, осн,	BIS[(3-METHYLDIMETHOXYSILYL)PROPYL]- POLYPROPYLENE OXIDE Hydrophilic dipodal silane W/tin catalyst forms moisture-cross-linkable resins HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water		>110°C (>230°F) 5,000-10,000 cSt.		1.00	1.452 <sup>25</sup>
	[75009-88-0] TSCA HMIS: 3-1-1-X	(	100g	2kg		
ochamanakan kansanaka Maria Lasa Maria	SIB1824.9  1,3-[BIS(3-TRIETHOXYSILYLPROPYL)POLYETHYLEN- OXY]-2-METHYLENEPROPANE  C <sub>50</sub> H <sub>104</sub> O <sub>20</sub> Si <sub>2</sub> (av)  Vinyl functional hydrophilic dipodal coupling agent for protein imm  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	1113.50	V			
	HMIS: 2-2-1-X	(	1.0g			
H <sub>3</sub> C CH <sub>3</sub> NCCHCH <sub>2</sub> CH <sub>2</sub> Si—CI	SIC2436.0 (3-CYANOBUTYL)DIMETHYLCHLOROSILANE C <sub>7</sub> H <sub>14</sub> CINSi	175.73	80-4 / 1		0.993	
CH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, proti HMIS: 3-2-1-X		25g	100g		
124362 CVIV	SIC2437.0	`		····		
NCCHCH2CH2SI—CH3	(3-CYANOBUTYL)METHYLDICHLOROSILANE $C_6H_{11}Cl_2NSi$	196.17	63 / 0.3		1.104	
CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, proti [71550-62-4] TSCA EC 275-613-1 HMIS: 3-2-1-X		25g	100g		
1222 000000	SIC2437.5	<u> </u>	209	1009		
H <sub>2</sub> C OCH <sub>3</sub> NCCHCH <sub>2</sub> CH <sub>2</sub> Si—CH <sub>3</sub> OCH <sub>4</sub>	(3-CYANOBUTYL)METHYLDIMETHOXYSILANE $C_8H_{17}NO_2Si$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	187.32 Flashpoint:	77 / 1.5 93°C (199°F)		0.947	1.4213 <sup>25</sup>
- Octig	[793681-94-4] TSCA HMIS: 3-2-1-X	(	25g			
işC ÇI     CCHCH₂CH₂ Şi−CI	SIC2438.0 (3-CYANOBUTYL)TRICHLOROSILANE C5H8CI3NSi	216.57	61-3 / 2		1.22	1.469 <sup>25</sup>
Ċľ	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, proti [163155-56-4] HMIS: 3-2-1-X		25g	100g		
C OCH2CH3 CHCH2CH2Si—OCH2CH3	SIC2439.0 3-CYANOBUTYLTRIETHOXYSILANE C <sub>11</sub> H <sub>23</sub> NO <sub>9</sub> Si	245.39				
OCH2CH3	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	HMIS: 2-2-1-X	(	25g			
N≡C−CH <sub>2</sub> CH <sub>2</sub> ,CI	SIC2440.0 2-CYANOETHYLMETHYLDICHLOROSILANE C <sub>4</sub> H <sub>7</sub> Cl <sub>2</sub> NSi Vapor pressure, 60°: 4 mm	168.10 Flashpoint:	60-4 / 4 60°C (140°F)		1.2015	1.4550 <sup>25</sup>
1130	Monomer for polar silicones used in GC phases HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, proti [1071-21-2] TSCA EC 213-985-9 HMIS: 3-2-1-X		25g			
	SIC2442.0 2-CYANOETHYLTRICHLOROSILANE	188.52		(32-3)	1.356	1.4615
N≡C−CH <sub>2</sub> CH <sub>2</sub> SiCl <sub>3</sub>	C <sub>3</sub> H <sub>4</sub> Cl <sub>3</sub> NSi  Vapor pressure, 85°: 12 mm  ΔHvap: 11.2 kcal/mole		oral rat, LD50: 2,000 mg/	<b>n</b> y		
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, proti [1071-22-3] TSCA EC 213-986-4 HMIS: 3-2-1-X		10g	50g		

	name	MW	bp/mm (mp)		D4 <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
	SIC2445.0					
	2-CYANOETHYLTRIETHOXYSILANE	217.34	224-5		0.9792	1.4140
$\text{mcCH}_2\text{CH}_2\text{Si}(\text{OC}_2\text{H}_5)_3$	C <sub>9</sub> H <sub>19</sub> NO <sub>3</sub> Si		86°C (187°F) oral rat, LD50: 5,630 mg/kg			
	Crosslinker for moisture-cure silicone RTVs - improves		oral rat, ED30. 3,030 mg/kg			
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/w	/ater				
		S: 2-2-0-X	25g	100g		2kg
	SIC2446.0	475.00			4.070	4 4400
	2-CYANOETHYLTRIMETHOXYSILANE	175.26	112 / 15		1.079	1.4126
$=C-CH_2CH_2Si(OCH_3)_3$	C <sub>6</sub> H <sub>13</sub> NO <sub>3</sub> Si yc of treated surfaces: 34 mN/m	Flashpoint	79°C (174°F)			
	Crosslinker for moisture-cure silicones - improves solve	nt resistance				
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/w	/ater				
	[2526-62-7] TSCA EC 219-764-3 HMI	S: 3-2-1-X	25g	100g		
	SIC2451.0					
	3-CYANOPROPYLDIISOPROPYL(DIMETHYLAMINO)-	226.44	96-8 / 0.2		0.89	
çн(си <sub>0</sub> ₂	SILANE 4-[DIMETHYLAMINOBIS(1-METHYLETHYL)SILYL]BUTANENITRIL	E				
*C=CH2CH2CH2S] =N(CH3)2	$C_{12}H_{26}N_2Si$	.L				
CH(CH-)2	Stable cyanofunctional bonded phase					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/w					
	-	S: 3-2-1-X	10g			
	SIC2452.0	101.71				4.4400
1/2402	3-CYANOPROPYLDIMETHYLCHLOROSILANE	161.71	108-9 / 15		0.986	1.4460
CH2	4-(CHLORODIMETHYLSILYL)BUTYRONITRILE C <sub>6</sub> H <sub>12</sub> CINSi	riasnpoint:	85°C (185°F)			
I=C-CH2CH2CH2Si-CI	Coupling agent for antibodies. <sup>1</sup>					
CH <sub>3</sub>	Allows formation of electrostatic gated nanopore electro	odes.2				
	1. Falipou, S. et al. Bioconjugate Chem. 1999, 10, 36.					
	2. Wang, G. et al. J. Am. Chem. Soc. 2006, 128, 7679.					
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,		25	400		
		S: 3-2-1-X	25g	100g		
C1	SIC2453.0	400.40			4 4 4 = 25	4 4554 25
i≡c−ch-ch-ch-si −ch-	3-CYANOPROPYLMETHYLDICHLOROSILANE C₅H₀Cl₂NSi	182.12	79-82 / 1 92°C (198°F)		1.145 <sup>25</sup>	1.4551 <sup>25</sup>
ČI	O51 19O121NO1	•	oral, rat, LD50: 2,830 mg/kg			
	Monomer for silicone films for microelectrodes permeab		3			
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,					
	· · · · · · · · · · · · · · · · · · ·	S: 3-2-1-X	25g	100g		
OCH,	SIC2453.5					
ч=с-сп₂сп₂сп₂s; -сп,	3-CYANOPROPYLMETHYLDIMETHOXYSILANE	173.29	82-3 / 3		0.9970	1.4235
OCII,	C <sub>7</sub> H <sub>15</sub> NO <sub>2</sub> Si See also SIC2437.5					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/w	vater				
		S: 3-2-1-X	5g	25g		
77.16	SIC2454.0					
CI	3-CYANOPROPYLTRICHLOROSILANE	202.54	93-4 / 8		1.302	1.465
NWC-CH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> S) -Cl	4-(TRICHLOROSILYL)BUTYRONITRILE	Flashpoint:	75°C (167°F)			
Ci	C <sub>4</sub> H <sub>6</sub> Cl <sub>3</sub> NSi HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,	water protic solvents				
		S: 3-2-1-X	25g	100g		
	SIC2455.0					
0C4It	3-CYANOPROPYLTRIETHOXYSILANE	231.37	79-80 / 0.6		0.961	1.4174
N≡C−CIPCIPCIPS) −0CPI	$C_{10}H_{21}NO_3Si$	•	74°C (165°F)			
OC-H1			oral rat, LD50: 2,460 mg/kg			
* 1	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/w	Viscosity: 2.	.JGJ 6.			
	•	S: 3-2-1-X	25g	100g		
	SIC2456.0	=	3			
QCH <sub>3</sub>	3-CYANOPROPYLTRIMETHOXYSILANE	189.29	90-2 / 7		1.027	1.4416
v≡с—сп-сп-сп-сп-si -осн-	C <sub>7</sub> H <sub>15</sub> NO <sub>3</sub> Si	.00.20				
OCH <sub>5</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/w					
	[55453-24-2] TSCA EC 259-646-9 HMI	S: 3-2-1-X	10g	50g		
	SIC2456.3					
NC(CH <sub>2</sub> ) <sub>11</sub> SiCl <sub>3</sub>	11-CYANOUNDECYLTRICHLOROSILANE	314.76	162-4 / 1		1.075	
Acres and the State Section 18	$C_{12}H_{22}CI_3NSi$					
	Long chain organificational aller-					
	Long chain organofunctional silane HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture,	water profic solvents				

# **Hydrophilic Silane Properties**

Polar - Hydrogen Bonding

	name		MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
0	SIA0006.0 ACETAMIDOPROPYLTRIMETHOXYSILANE		221.33	162-5 / 2-3			1.441
ENHCH2CH2CH2Si(OCH3)	C₀H₁₀NO₄Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo		2200				
F-10-20	[57757-66-1]	HMIS: 3-2-1-X		10g			
H <sub>2</sub> COCH <sub>2</sub> CH <sub>2</sub> Si —CI CH <sub>2</sub>	SIA0010.0 ACETOXYETHYLDIMETHYLCHLOROSILANE $C_6H_{13}CIO_2Si$		180.71 Flashpoint: 6	108-9 / 50 3°C (145°F)		1.031 25	1.4301 25
3-713	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mo [18306-45-1]	oisture, water, protic so HMIS: 3-2-1-X	vents	25g			
S &:	SIA0015.0						
н <sub>ь</sub> ёосн <sub>э</sub> сн <sub>э</sub> ў —сн <sub>э</sub> сі	$\begin{split} &\text{ACETOXYETHYLMETHYLDICHLOROSILANE} \\ &C_5H_{10}Cl_2O_2Si \\ &\text{HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mix} \end{split}$	oisture, water, protic so	201.12 Flashpoint: 6 vents	117 / 62 5°C (149°F)		1.177 25	1.4390 <sup>25</sup>
	[18163-34-3] TSCA EC 242-045-0	HMIS: 3-2-1-X		25g			
H²COCH³CH²Si —CI	SIA0020.0 ACETOXYETHYLTRICHLOROSILANE $C_4H_7Cl_3O_2Si$		221.54 Flashpoint: 8	143 / 70 2°C (180°F)		1.272 <sup>25</sup>	1.4427 <sup>25</sup>
CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with me		vents	25~	100~		
	[18204-80-3] TSCA EC 242-092-7	HMIS: 3-2-1-X		25g	100g		
O OC <sub>2</sub> H <sub>5</sub>	SIA0025.0 ACETOXYETHYLTRIETHOXYSILANE C <sub>10</sub> H <sub>22</sub> O <sub>5</sub> Si		250.37	60 / 0.2		0.983	1.410
OC3H2 OC3H2	>280° rearranges to acetoxytriethoxysilane w/ ex 1. Ezbiansky, K. A. et al. Chemical Processing of Diele HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo [22538-45-0]	ectrics, Insulators & Ele	ctronic Ceramics,	, MRS Proc. <b>2000</b> ; <i>606</i> , 251.			
	SIA0030.0						
O OCH <sub>3</sub> I <sub>3</sub> COCH <sub>2</sub> CH <sub>2</sub> Si-OCH <sub>3</sub>	ACETOXYETHYLTRIMETHOXYSILANE, 95% C <sub>7</sub> H <sub>16</sub> O <sub>6</sub> Si		208.29	108-9 / 27		1.061	
The second secon							
OCH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo			05			
OCH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo [72878-29-6] TSCA	bisture/water HMIS: 3-3-1-X		25g			
O CH <sub>3</sub> O	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo		190.27 Flashpoint: 6	66-9 / 7		1.0420	1.4388
Q ÇH3 Q I3COCH2Şi -OCCH3	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mo [72878-29-6] TSCA SIA0040.0 ACETOXYMETHYLDIMETHYLACETOXYSILANE	HMIS: 3-3-1-X		66-9 / 7 3°C (145°F)		1.0420	1.4388
O CH3 O	HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [72878-29-6] TSCA SIA0040.0 ACETOXYMETHYLDIMETHYLACETOXYSILANE C <sub>7</sub> H <sub>14</sub> O <sub>4</sub> Si	HMIS: 3-3-1-X		66-9 / 7		1.0420	1.4388
о сн, о 1,coch, si – оссн, сн,	HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [72878-29-6] TSCA  SIA0040.0  ACETOXYMETHYLDIMETHYLACETOXYSILANE  C <sub>7</sub> H <sub>14</sub> O <sub>4</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [5833-57-8]  SIA0050.0  ACETOXYMETHYLTRIETHOXYSILANE	HMIS: 3-3-1-X		66-9 / 7 3°C (145°F)		1.0420	1.4388
О СН3 О ИзСОСН2SI −ОССН3 СН3	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [72878-29-6] TSCA	HMIS: 3-3-1-X  bisture/water HMIS: 3-2-1-X  utral water bisture/water	Flashpoint: 6	66-9 / 7 3°C (145°F) 25g 106 / 15	1000		
Q CH <sub>3</sub> Q I <sub>3</sub> COCH <sub>2</sub> Si = OCCH <sub>3</sub> CH <sub>3</sub> Q QC <sub>2</sub> H <sub>5</sub> I <sub>3</sub> COCH <sub>2</sub> Si = OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [72878-29-6] TSCA SIA0040.0 ACETOXYMETHYLDIMETHYLACETOXYSILANE $C_7H_{14}O_4Si$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [5833-57-8] SIA0050.0 ACETOXYMETHYLTRIETHOXYSILANE $C_9H_{20}O_5Si$ Hydrolyzes to form stable silanol solutions in neu HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [5630-83-1]	HMIS: 3-3-1-X  pisture/water HMIS: 3-2-1-X	Flashpoint: 6	66-9 / 7 :3°C (145°F) 25g	100g		
O CH <sub>3</sub> O  I <sub>3</sub> COCH <sub>2</sub> Si – OCCH <sub>3</sub> CH <sub>3</sub> O C <sub>2</sub> H <sub>5</sub> I <sub>3</sub> COCH <sub>2</sub> Si – OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub> O OCH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [72878-29-6] TSCA	HMIS: 3-3-1-X  bisture/water HMIS: 3-2-1-X  utral water bisture/water	Flashpoint: 6	66-9 / 7 3°C (145°F) 25g 106 / 15 25g	100g		
O CH <sub>3</sub> O  H <sub>3</sub> COCH <sub>2</sub> Si - OCCH <sub>3</sub> CH <sub>3</sub> O C <sub>2</sub> H <sub>5</sub> H <sub>3</sub> COCH <sub>2</sub> Si - OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [72878-29-6] TSCA SIA0040.0   ACETOXYMETHYLDIMETHYLACETOXYSILANE $C_7H_14O_4Si$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [5833-57-8] SIA0050.0   ACETOXYMETHYLTRIETHOXYSILANE $C_9H_{20}O_9Si$ Hydrolyzes to form stable silanol solutions in neu HYDROLYTIC SENSITIVITY: 7: reacts slowly with mot [5630-83-1] SIA0055.0   ACETOXYMETHYLTRIMETHOXYSILANE, 95%	HMIS: 3-3-1-X  pisture/water HMIS: 3-2-1-X  utral water pisture/water HMIS: 2-2-1-X	Flashpoint: 6 236.34	66-9 / 7 3°C (145°F) 25g 106 / 15 25g	100g 50g	1.042 25	1.4092
O CH <sub>3</sub> O  H <sub>3</sub> COCH <sub>2</sub> Si = OCCH <sub>3</sub> CH <sub>3</sub> O OC <sub>2</sub> H <sub>5</sub> H <sub>3</sub> COCH <sub>2</sub> Si = OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub> OCH <sub>3</sub> OCH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [72878-29-6] TSCA  SIA0040.0  ACETOXYMETHYLDIMETHYLACETOXYSILANE  C7H14O4Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [5833-57-8]  SIA0050.0  ACETOXYMETHYLTRIETHOXYSILANE  C9H20O5Si Hydrolyzes to form stable silanol solutions in neuron hydrolytic sensitivity: 7: reacts slowly with motor [5630-83-1]  SIA0055.0  ACETOXYMETHYLTRIMETHOXYSILANE, 95%  C9H14O5Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [65625-39-0]  TSCA-L  SIA0078.0  2-[(ACETOXY(POLYETHYLENEOXY)PROPYL]-TRIETHOXYSILANE, 95%	HMIS: 3-3-1-X  Disture/water HMIS: 3-2-1-X  Lutral water Disture/water HMIS: 2-2-1-X  Disture/water	Flashpoint: 6 236.34	66-9 / 7 3°C (145°F) 25g 106 / 15 25g 190-1 6°C (133°F)	·	1.042 25	1.4092
Q CH <sub>3</sub> Q CH <sub>3</sub> COCH <sub>2</sub> Si - OCCH <sub>3</sub> CH <sub>3</sub> Q QC <sub>2</sub> H <sub>5</sub> CH <sub>3</sub> COCH <sub>2</sub> Si - OC <sub>2</sub> H <sub>5</sub> OC <sub>2</sub> H <sub>5</sub> Q QCH <sub>5</sub> CH <sub>3</sub> COCH <sub>2</sub> Si - OCH <sub>3</sub>	HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [72878-29-6] TSCA  SIA0040.0  ACETOXYMETHYLDIMETHYLACETOXYSILANE  C7H14O4Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [5833-57-8]  SIA0050.0  ACETOXYMETHYLTRIETHOXYSILANE  C9H20O5Si Hydrolyzes to form stable silanol solutions in neuron hydrolytic sensitivity: 7: reacts slowly with motor [5630-83-1]  SIA0055.0  ACETOXYMETHYLTRIMETHOXYSILANE, 95%  C9H14O5Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with motor [65625-39-0]  TSCA-L  SIA0078.0  2-[(ACETOXY(POLYETHYLENEOXY)PROPYL]-TRIETHOXYSILANE, 95%	HMIS: 3-3-1-X  Disture/water HMIS: 3-2-1-X  Utral water Disture/water HMIS: 2-2-1-X  Disture/water HMIS: 3-2-1-X	Flashpoint: 6 236.34 194.26 Flashpoint: 5	66-9 / 7 3°C (145°F) 25g 106 / 15 25g 190-1 6°C (133°F)	·	1.042 <sup>25</sup>	1.4092

	name	MW	bp/mm (r	np)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
	SIA0090.0					
cu cu cu e -cu	ACETOXYPROPYLMETHYLDICHLOROSILANE	215.15	142 / 73		1.151 <sup>25</sup>	1.4434 <sup>25</sup>
сн <sub>2</sub> сн <sub>3</sub> сн <sub>3</sub> § –сп <sub>3</sub>	$C_6H_{12}CI_2O_2Si$	Flashpoint: 85				
CI	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr	rotic solvents				
	[5290-24-4] TSCA EC 226-126-8 HMIS: 3-2-1	-X	25g			
700011	SIA0100.0					
осн,	ACETOXYPROPYLTRIMETHOXYSILANE	222.31	92/2		1.062	1.4146
H <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> Si —OCH	0811180501	Flashpoint: 93	°C (199°F)			
OCH	γc of treated surfaces: 37.5 mN/m					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	V	05	400		
	[59004-18-1] EC 261-552-8 HMIS: 3-1-1	-X	25g	100g		
)	SIA0114.0					
OCH <sub>2</sub> (CH <sub>2</sub> ) <sub>10</sub> SiCl <sub>3</sub>	11-ACETOXYUNDECYLTRICHLOROSILANE	347.78	147-9 / 1		1.084	
OCTIZICITZ/1051Ci3	C <sub>13</sub> H <sub>25</sub> Cl <sub>3</sub> O <sub>2</sub> Si	Flashpoint: >1	10°C (>230°F)			
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr [53605-77-9] HMIS: 3-1-1		10g			
	<u></u>	-^	109			
OC <sub>2</sub> H <sub>5</sub>	SIA0115.0	070.04				
O(CH <sub>2</sub> ) <sub>11</sub> Si —OC <sub>2</sub> H <sub>5</sub>	11-ACETOXYUNDECYLTRIETHOXYSILANE	376.61				
OC <sub>2</sub> H <sub>5</sub>	C <sub>19</sub> H <sub>40</sub> O <sub>5</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	[959053-85-1] HMIS: 2-2-1	-X	1.0g			
	SIA0120.2		9			
	(N-ACETYLGLYCYL)-3-AMINOPROPYLTRIMETHOXY-	278.38		(171-3)	0.80	
	SILANE, 5% in methanol	Flashpoint: 15	°C (50°E)	(171-3)	0.00	
0	C <sub>10</sub> H <sub>22</sub> N <sub>2</sub> O <sub>5</sub> Si	i iasripoliti. 13	C (39 1 )			
ICH CANACH VEING	Amine eaid tinned ailene					
ICH <sub>2</sub> CNH(CH <sub>2</sub> ) <sub>3</sub> Si(OC	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	HMIS: 3-4-1	-X	25g			
	SIA0599.4		-			
	N-3-[(AMINO(POLYPROPYLENOXY)]AMINOPROPYL-	337-435			0.984	1.4508
					0.00	
	TRIMETHUXYSILANE 60 - 65% 3-4 propyler	noxy units				
CHI	TRIMETHOXYSILANE, 60 - 65%  3-4 propyler  Contains amine-terminated polypropylene oxide	noxy units				
кренечосичения петра	Contains amine-terminated polypropylene oxide	noxy units				
1 1 1		noxy units				
кренечосичения петра	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.	·	25g			
кренечосичения петра	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	·	25g			
кренечосичения петра	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1	·	25g 145 / 0.2		1.104	1.4806
S STICHT SOLFCHONGERONS	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1 SIB0959.0	-X	- 3		1.104	1.4806
кренечосичения петра	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1 SIB0959.0 BENZOYLOXYPROPYLTRIMETHOXYSILANE	-X	- 3		1.104	1.4806
S STICHT SOLFCHONGERONS	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si	-X 284.38	- 3		1.104	1.4806
S STICHT SOLFCHONGERONS	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	-X 284.38	145 / 0.2		1.104	1.4806
ор — с—о(сиэ/s/(осиэ/	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1	-X 284.38	145 / 0.2		1.104	1.4806
сиченэчен В состанения	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1	-X 284.38	145 / 0.2 25g			1.4806
ор — с—о(сиэ/s/(осиэ/	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub>	-X 284.38	145 / 0.2 25g			1.4806
сичентя	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6]  TSCA  HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity	284.38 2-X 583.40	145 / 0.2 25g			1.4806
CH-(CH-)-SHOCH-)	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6]  TSCA  HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>16</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr	284.38 2-X 583.40 rotic solvents	145 / 0.2 25g 190-200 / 0.4			1.4806
сичентя	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6]  TSCA  HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>16</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, properties and the state of the st	284.38 2-X 583.40 rotic solvents	145 / 0.2 25g			1.4806
сичентя	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6]  TSCA  HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>16</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr	284.38 2-X 583.40 rotic solvents	145 / 0.2 25g 190-200 / 0.4			1.4806
сичентя	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6]  TSCA  HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>16</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, properties and the state of the st	284.38 2-X 583.40 rotic solvents	145 / 0.2 25g 190-200 / 0.4			1.4806
сичентя	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>28</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1	284.38  -X  583.40  rotic solvents -X	145 / 0.2 25g 190-200 / 0.4		1.158	1.4806
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub>	284.38  -X  583.40  rotic solvents -X  597.42	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	1.4806
сичентя	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>25</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph	284.38  2-X  583.40  rotic solvents  -X  597.42	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	1.4806
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>15</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	1.4806
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>26</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydrophydrophydrolytic SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	1.4806
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>15</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>26</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydrophydrophydrolytic SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	1.4806 1.4583 <sup>25</sup>
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>26</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158	
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>26</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N'-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9		1.158  1.135  1.088  coatings can be	
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N'-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-CARBONYL]POLYETHYLENE OXIDE (10-15 EO)	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from	1.158  1.135  1.088  coatings can be combinations of	
CH-(CH2)-Si(OCH2)  CH-(CH2)-Si(OCH2)  CH-(CH2)-SiCH  CH-(CH2)-SiCH	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>36</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N'-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-CARBONYL]POLYETHYLENE OXIDE (10-15 EO)  UREASIL	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from polyalkylene	1.158  1.135  1.088  coatings can be	
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N'-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-CARBONYL]POLYETHYLENE OXIDE (10-15 EO)  UREASIL  Dipodal hydrophilic silane	284.38  284.38  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X  1,000 - 1,200	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from polyalkylene silanes a	1.158  1.135  1.088  coatings can be combinations of oxide functional	
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI   Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-CARBONYL]POLYETHYLENE OXIDE (10-15 EO)  UREASIL  Dipodal hydrophilic silane  Viscosity: 300-350 cSt  In combination with sulfolane forms gel electrolyte for solar cell:	284.38  284.38  -X  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X  1,000 - 1,200  s.1	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from polyalkylene silanes a	1.158  1.135  1.088  coatings can be combinations of oxide functional and film-forming		
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI	Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>3</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr  [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-CARBONYL]POLYETHYLENE OXIDE (10-15 EO)  UREASIL  Dipodal hydrophilic silane  Viscosity: 300-350 cSt  In combination with sulfolane forms gel electrolyte for solar cell:	284.38  284.38  -X  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X  1,000 - 1,200  s.1	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from polyalkylene silanes a	1.158  1.135  1.088  coatings can be combinations of oxide functional and film-forming	
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI   Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N'-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO- CARBONYL]POLYETHYLENE OXIDE (10-15 EO)  UREASIL  Dipodal hydrophilic silane Viscosity: 300-350 cSt In combination with sulfolane forms gel electrolyte for solar celli-	284.38  284.38  -X  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X  1,000 - 1,200  s.1	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from polyalkylene silanes a	1.158  1.135  1.088  coatings can be combinations of oxide functional and film-forming		
CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> Si(OCH <sub>2</sub> )  CH <sub>2</sub> (CH <sub>2</sub> ) <sub>2</sub> SiCI   Contains amine-terminated polypropylene oxide Coupling agent with film-forming capability.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 2-2-1  SIB0959.0  BENZOYLOXYPROPYLTRIMETHOXYSILANE  C <sub>13</sub> H <sub>20</sub> O <sub>5</sub> Si  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [76241-02-6] TSCA HMIS: 3-2-1  SIB1815.1  1,3-BIS(3-TRICHLOROSILYLPROPOXY)-2-DECYLOXY-PROPANE  C <sub>19</sub> H <sub>38</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal C <sub>18</sub> analog with embedded hydrophilicity HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr [862912-02-5] HMIS: 3-1-1  SIB1815.3  3,3-BIS(TRICHLOROSILYLPROPOXYMETHYL)- 5-OXA-TRIDECANE, 95%  C <sub>20</sub> H <sub>40</sub> Cl <sub>6</sub> O <sub>3</sub> Si <sub>2</sub> Dipodal hydrophobic surface treatment with embedded hydroph HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, pr [862911-99-7] HMIS: 3-1-1  SIB1824.82  N,N'-BIS-[(3-TRIETHOXYSILYLPROPYL)AMINO-CARBONYL]POLYETHYLENE OXIDE (10-15 EO)  UREASIL  Dipodal hydrophilic silane  Viscosity: 300-350 cSt  In combination with sulfolane forms gel electrolyte for solar cell- Forms proton conducting hybrid organic-inorganic polymer elec- 1. Stathatos, E. et al. Adv. Funct. Mater. 2004, 14, 45.	284.38  284.38  -X  583.40  rotic solvents -X  597.42  nobicity for chromatograrotic solvents -X  1,000 - 1,200  s.1	145 / 0.2  25g  190-200 / 0.4  10g  220-2 / 0.9	formed from polyalkylene silanes a	1.158  1.135  1.088  coatings can be combinations of oxide functional and film-forming		

	name		MW	bp/mm (m	p)	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
Cally 0	SID4465.0 N,N-DIOCTYL-N'-TRIETHOXYSILYLPROPYLUREA		488.83			0.924 <sup>25</sup>	1.4521 25
Callin	$\begin{split} &C_{2\theta}H_{5\theta}N_2O_4Si\\ &Forms\ hydrophobic\ phases\ with\ embedded\ hydrop\\ &Forms\ organic-inorganic\ vesicles\ (cerasomers).^1\\ &1.\ Hashizume,\ M.\ et\ al.\ {\it J.\ Thin\ Solid\ Films\ }\ {\bf 2003,\ 4.} \end{split}$	38, 20.	400.03			0.924	1.4021
	<u> </u>	HMIS: 2-2-1-X		25g			
\$	SID4472.0 4,7-DIOXAOCTADECYLTRICHLOROSILANE, 95% $C_{10}H_{33}Cl_3O_2Si$ Forms $C_{18}$ bonded phases with embedded hydroph HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	,	391.88	165 / 0.7		1.028	
a / a	•	HMIS: 3-1-1-X		10g			
CH3OCH2CH2O(CH2011SiCl3	SIM6491.5  METHOXYETHOXYUNDECYLTRICHLOROSILANE  C <sub>14</sub> H <sub>29</sub> Cl <sub>3</sub> O <sub>2</sub> Si  Forms self-assembled monolayers with "hydrophillic		363.83	145-9 / 1.25		1.07	
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois [943349-49-3]	HMIS: 3-2-1-X	ents	5g			
	SIM6492.58			-9			
$CH_3$ $CH_3O-(CH_2CH_2O)$ — $(CH_2O)_3Si-OCH_3$ $CH_3$	2-[METHOXYPOLY(ETHYLENOXY) <sub>6-9</sub> PROPYL]- DIMETHYLMETHOXYSILANE CH <sub>3</sub> O(C <sub>2</sub> H <sub>4</sub> O) <sub>6-9</sub> (CH <sub>2</sub> ) <sub>3</sub> (CH <sub>3</sub> ) <sub>2</sub> Si(OCH <sub>3</sub> )		427-559				
City	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ture/water HMIS: 2-2-1-X		5g			
	SIM6492.66 2-[METHOXY(POLYETHYLENEOXY)PROPYL]-	TIIVIIO. Z-Z-1-A	472-604			1.13	
CH <sub>3</sub> O=(CH <sub>2</sub> CH <sub>2</sub> O) <sub>6.9</sub> =(CH <sub>2</sub> ) <sub>3</sub> Sit	TRICHLOROSILANE, tech-90  CH <sub>3</sub> O(C <sub>2</sub> H <sub>4</sub> O) <sub>6-9</sub> (CH <sub>2</sub> ) <sub>3</sub> Cl <sub>3</sub> Si  Forms hydrophilic surfaces  Provides protein antifouling surface.  1. Cecchet, F. et al. <i>Langmuir</i> <b>2006</b> , <i>22</i> , 1173  HYDROLYTIC SENSITIVITY: 8: reacts rapidly with mois	turo water profis colle	vente				
		HMIS: 3-2-1-X	ents	10g			
CH <sub>3</sub> O~(CH <sub>2</sub> CH <sub>2</sub> O) <sub>6-9</sub> (CH <sub>2</sub> ) <sub>3</sub> Si(OCH	SIM6492.7 2-[METHOXY(POLYETHYLENEOXY)PROPYL]- TRIMETHOXYSILANE, tech-90 CH <sub>3</sub> (C <sub>2</sub> H <sub>4</sub> O) <sub>6-9</sub> (CH <sub>2</sub> ) <sub>3</sub> OSi(OCH <sub>3</sub> ) <sub>3</sub> Reduces non-specific binding of proteins Forms charge neutral coatings on CdSe quantum of 1. Parak, W. et al. <i>Chem. Mater.</i> 2002, <i>14</i> , 2113. See also SIB1824.84, SIH6188.0	dots which conujuga	459-591 Flashpoint: 8 Viscosity: 29 te DNA. <sup>1</sup>		(-8)	1.076	1.403
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist [65994-07-2] TSCA	ture/water HMIS: 2-2-1-X		25g	100g		
	SIM6492.72	1 IVIIO. 2 2-1-X		209	1009		25
CH <sub>2</sub> O (CH <sub>2</sub> CH <sub>2</sub> O <sub>3+12</sub> (CH <sub>2</sub> ) <sub>2</sub> Sk(OCH <sub>2</sub> )	2-[METHOXY(POLYETHYLENEOXY)PROPYL]- TRIMETHOXYSILANE, tech-90 CH <sub>3</sub> (C <sub>2</sub> H <sub>4</sub> O) <sub>9-12</sub> (CH <sub>2</sub> ) <sub>3</sub> OSi(OCH <sub>3</sub> ) <sub>3</sub> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist	ture/water	591-719 Flashpoint: 8	8°C (190°F)		1.071	1.451 <sup>25</sup>
		HMIS: 2-2-1-X		25g	100g		
$CH_{I}O(CH_{I}CH_{I}O)_{I_{I},I_{I}}(CH_{I})_{I}Si(OCH_{I})_{I}$	SIM6492.73 2-[METHOXY(POLYETHYLENEOXY)PROPYL] TRIMETHOXYSILANE, tech-90 CH <sub>3</sub> O(CH <sub>2</sub> CH <sub>2</sub> O) <sub>21.4</sub> (CH <sub>2</sub> ) <sub>3</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>		900-1,200				
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moist [65994-07-2]	ture/water HMIS: 2-2-1-X		1.0g			

	name		MW	bp/mm (mp)		D4 <sup>20</sup>	$n_{\scriptscriptstyle D}^{\scriptscriptstyle 20}$	
	SIM6493.0							
en cen en en ekoen i	3-METHOXYPROPYLTRIMETHOXYSILANE		194.30	98-9 / 40		0.995		
CH <sub>2</sub> OCH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	$C_7H_{18}O_4Si$		Flashpoint: 5	53°C (127°F)				
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture							
	[33580-59-5] HM	MIS: 3-2-1-X		25g	100g			
	SIM6493.2							
ett even ett et vert i etel	METHOXYTRIETHYLENEOXYPROPYLTRICHLORO-		339.71	148 / 0.3		1.034		
CH <sub>2</sub> O(CH <sub>2</sub> CH <sub>2</sub> O) <sub>3</sub> (CH <sub>2</sub> ) <sub>3</sub> SiCl <sub>3</sub>	SILANE							
	C <sub>10</sub> H <sub>21</sub> Cl <sub>3</sub> O <sub>4</sub> Si							
	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture	e, water, protic solve VIS: 3-2-1-X	ents	10g				
	· · · · · · · · · · · · · · · · · · ·	VIIS. 3-2-1-A		109				
	SIM6493.4		000.40	440.40.0		4.400	4 4004	
	METHOXYTRIETHYLENEOXYPROPYLTRIMETHOXY- SILANE		326.46	140 / 0.2		1.163	1.4321	
	C <sub>13</sub> H <sub>30</sub> O <sub>7</sub> Si							
$H_1O$ ( $CH_2CH_2O$ ), $(CH_2)_1Si(OCH_2)$	Forms polymeric proton-conducting electrolytes. <sup>1</sup>							
	1. Ritchie, J. et al. <i>Chem. Mater.</i> <b>2006</b> , <i>18</i> ,504.							
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture	e/water						
	•	MIS: 3-2-1-X		10g				
	SIM6493.7			-				
	METHOXYTRIETHYLENEOXYUNDECYLTRIMETHOXY-		438.68					
	SII ANE							
CH <sub>3</sub> O-(CH <sub>2</sub> CH <sub>2</sub> O) <sub>3</sub> -(CH <sub>2</sub> ) <sub>11</sub> Si(OCH <sub>3</sub> )	3 PEG3C11 Silane							
	$C_{21}H_{46}O_7Si$							
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture							
		MIS: 3-2-1-X		1.0g				
	SIT7122.6							
OC <sub>2</sub> H <sub>5</sub> OCH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> Si –OC <sub>2</sub> H <sub>5</sub>	TETRAHYDROFURFURYLOXYPROPYL-		306.47	130 / 0.3		0.990		
OC.Hs	TRIETHOXYSILANE							
	C <sub>14</sub> H <sub>30</sub> O <sub>5</sub> Si							
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture	e/water MIS: 1-2-1-X		10g				
		VIIS. 1-2-1-A		109				
	SIT8186.0		204 EC	400 4 / 0 4		1 100		
- o-critariocritarianismocritari	(2-TRIETHOXYSILYLPROPOXY)ETHOXYSULFOLANE C <sub>15</sub> H <sub>32</sub> O <sub>7</sub> SSi 95%		384.56	190-4 / 0.4		1.122		
<b>V</b>	Forms hydrophilic surfaces							
7"0	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture	e/water						
	•	MIS: 2-2-1-X		10g				
	SIT8186.3							
	TRIETHOXYSILYLPROPOXY(POLYETHYLENEOXY)-		536.82			0.977	1.4479 <sup>25</sup>	
осы сынысо(спьсньоь(спь),si⊷осы	DODECANOATE (2 EQ unita)							
And the second of the second o	$C_{27}H_{56}O_8Si$							
(RoH)	C <sub>27</sub> H <sub>56</sub> O <sub>8</sub> Si Contact angle (treated surface), water: 61-2°							
And the second of the second o	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate							
Annual Control of the	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com							
Secretaria de la constante de la Constante de	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions. <sup>1</sup>	patibility						
Secretaria de la constante de la Constante de	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.  1. Arkles, B. et al. in Silanes and Other Coupling Ager	patibility  nts; Mittal, K., Ed.	; VSP (Brill), :	2009, Vol. 5, p. 51.				
And the second of the second o	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.  1. Arkles, B. et al. in Silanes and Other Coupling Ager HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture	patibility nts; Mittal, K., Ed. e/water	; VSP (Brill), :					
And the second of the second o	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.  1. Arkles, B. et al. in Silanes and Other Coupling Ager HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture  [1041420-54-5]	patibility  nts; Mittal, K., Ed.	; VSP (Brill), :	2009, Vol. 5, p. 51. 10g				
Annual Control of the	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹ 1. Arkles, B. et al. in Silanes and Other Coupling Ager HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture  [1041420-54-5] HI SIT8717.0	patibility nts; Mittal, K., Ed. e/water						
OC;Hi	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹ 1. Arkles, B. et al. in Silanes and Other Coupling Ager HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture [1041420-54-5] HI SIT8717.0 TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE	patibility nts; Mittal, K., Ed. e/water	615.86	10g		1.170	1.4610	
Secretaria de la constante de la Constante de	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹ 1. Arkles, B. et al. in <i>Silanes and Other Coupling Ager</i> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture  [1041420-54-5] HI SIT8717.0 TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE C <sub>21</sub> H <sub>48</sub> N <sub>3</sub> O <sub>12</sub> Si <sub>3</sub> tech-95	patibility nts; Mittal, K., Ed. e/water	615.86			1.170	1.4610	
OC <sub>2</sub> H <sub>6</sub>	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹  1. Arkles, B. et al. in <i>Silanes and Other Coupling Ager</i> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture  [1041420-54-5] HI SIT8717.0  TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE  C21H4sN3O12Si3 tech-95 Viscosity: 325-350 cSt.	patibility nts; Mittal, K., Ed. e/water	615.86	10g		1.170	1.4610	
OC;Hi	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹ 1. Arkles, B. et al. in <i>Silanes and Other Coupling Ager</i> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture  [1041420-54-5] HI SIT8717.0 TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE C <sub>21</sub> H <sub>45</sub> N <sub>3</sub> O <sub>12</sub> Si <sub>3</sub> tech-95 Viscosity: 325-350 cSt. Adhesion promoter for hotmelt adhesives	patibility nts; Mittal, K., Ed. e/water	615.86	10g		1.170	1.4610	
OC,Hi	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹  1. Arkles, B. et al. in Silanes and Other Coupling Ager HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture [1041420-54-5]  SIT8717.0  TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE C21H4sN3O12Si3 tech-95 Viscosity: 325-350 cSt. Adhesion promoter for hotmelt adhesives Coupling agent for polyimides to silicon metal	patibility nts; Mittal, K., Ed. e/water	615.86	10g		1.170	1.4610	
OC,Hi	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹ 1. Arkles, B. et al. in <i>Silanes and Other Coupling Ager</i> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture  [1041420-54-5] HI SIT8717.0 TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE C <sub>21</sub> H <sub>48</sub> N <sub>3</sub> O <sub>12</sub> Si <sub>3</sub> tech-95 Viscosity: 325-350 cSt. Adhesion promoter for hotmelt adhesives Coupling agent for polyimides to silicon metal Forms periodic mesoporous silicas.¹	patibility nts; Mittal, K., Ed. e/water	615.86	10g		1.170	1.4610	
OCHI	Contact angle (treated surface), water: 61-2° Contact angle (treated surface), 2-ethylhexyl palmitate Provides embedded hydrophilicity with oleophilic com Surface treatments stabilize particle dispersions.¹  1. Arkles, B. et al. in Silanes and Other Coupling Ager HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture [1041420-54-5]  SIT8717.0  TRIS(3-TRIMETHOXYSILYLPROPYL)ISOCYANURATE C21H4sN3O12Si3 tech-95 Viscosity: 325-350 cSt. Adhesion promoter for hotmelt adhesives Coupling agent for polyimides to silicon metal	patibility nts; Mittal, K., Ed. e/water MIS: 2-1-1-X	615.86	10g		1.170	1.4610	

# Hydrophilic Silane Properties Hydroxylic

	name		MW b	p/mm (mp)		D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>
HO COCH,CH,CH,SHOC,H,	SIA0126.0 3-(N-ACETYL-4-HYDROXYPROLYL)PROPYL- TRIETHOXYSIANE, 25% in ethanol C <sub>16</sub> H <sub>31</sub> NO <sub>7</sub> Si Hydrophilic reagent for biomimetic surface modific HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi-	sture/water	377.51			0.872	
	OID4440.0	HMIS: 2-3-0-X		5g			
HOCH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> SHOE	SIB1140.0  BIS(2-HYDROXYETHYL)-3-AMINOPROPYLTRIETHO.  SILANE, 62% in ethanol  C <sub>13</sub> H <sub>31</sub> NO <sub>5</sub> Si  Contains 2-3% hydroxyethylaminopropyltriethoxys  Urethane polymer coupling agent  Employed in surface modification for preparation of 1. McGall, G. et al. <i>Proc. Natl. Acad. Sci.</i> 1996, 93  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moin	silane of oligonucleotide arra 3, 1355.	309.48 Flashpoint: 24°C (75°F) Specific wetting surface ays. <sup>1</sup>			0.92	1.4090 <sup>25</sup>
	[7538-44-5] TSCA EC 231-408-9	HMIS: 3-4-0-X		25g	100g		
посизсиз	SIB1142.0 N,N'-BIS(HYDROXYETHYL)-N,N'-BIS(TRIMETHOXY- SILYLPROPYL)ETHYLENEDIAMINE, 66-68% in methal	anol	472.73			0.98	
(си,оъзисио),	C <sub>18</sub> H <sub>44</sub> N <sub>2</sub> O <sub>8</sub> Si <sub>2</sub> HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi:	sture/water	Flashpoint: 11°C (52°F)				
	[214362-07-9]	HMIS: 3-4-1-X		25g			
ocalianianiano, cultura for locosis	SIB1824.2 BIS-[3-(TRIETHOXYSILYLPROPOXY)-2-HYDROXY-PROPOXY]POLYETHLYENE OXIDE, 65% in ethanol $C_{24}H_{54}O_{11}S_{12}(C_2H_4O)_{5.8}$ HYDROLYTIC SENSITIVITY: 7: reacts slowly with moin strength of the st	sture/water	800 - 900 Flashpoint: 24°C (75°F)			0.959	1.421
		HMIS: 2-4-1-X		25g			
спустьстустумосяту, попустустумосяту, спустустумосяту	SIB1824.4 2,2-BIS(3-TRIETHOXYSILYLPROPOXYMETHYL)-BUTANOL, 50% in ethanol $C_{24}H_{54}O_9Si_2$		542.86			0.899	
Performance of the Control of the	For solid-state synthesis of oligonucleotides	LIMIC: 2 4 1 V		10g			
	[862911-98-6] SIH6172.0	HMIS: 2-4-1-X		109			
иче, менченченчаемоси»	N-(HYDROXYETHYL)-N-METHYLAMINOPROPYLTRIMETHOXYSILANE, 75% in methanol $C_{\text{g}}H_{\text{ZB}}\text{NO}_{\text{d}}\text{Si}$		237.37 Flashpoint: 16°C (61°F)			0.99	1.417
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi:	sture/water HMIS: 3-4-1-X		25g	100g		
	[330457-46-0] SIH6175.0	11W13. 3-4-1-X		239	1009		
OC3H; NO:CH2-Si-OC3H4 OC3H;	HYDROXYMETHYLTRIETHOXYSILANE, 50% in ethat TRIETHOXYSILYLMETHANOL $C_7H_{18}O_4Si$	nol	194.31			0.866	
005111 005111 005111 005111	Contains equilibrium condensation oligomers Hydrolysis yields analogs of silica-hydroxymethyls  1. Arkles, B. US Patent 5,371,262, 1994. HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi-						
	[162781-73-9]	HMIS: 2-4-0-X		25g			
0C3H2 0C3H3	SIH6188.0 [HYDROXY(POLYETHYLENEOXY)PROPYL]- TRIETHOXYSILANE, (8-12 EO), 50% in ethanol HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi-		575-750			0.889	1.401
0	CIT0400 0	HMIS: 2-4-1-X		25g			
7-8000 (5600 (315)) 0011 1011 1100	SIT8189.0 N-(3-TRIETHOXYSILYLPROPYL)GLUCONAMIDE C <sub>15</sub> H <sub>33</sub> NO <sub>9</sub> Si 50% in ethanol Water soluble, hydrophilic silane HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moi	isture, water, protic solv	399.51 Flashpoint: 8°C (46°F) ents			0.951	
Citions	[104275-58-3]	HMIS: 2-4-1-X		25g	100g		
0	SIT8189.5 N-(3-TRIETHOXYSILYLPROPYL)-4-HYDROXY- BUTYRAMIDE		307.47			1.02	1.4533
neuvicii Steitaivisiiseiiii	C <sub>13</sub> H <sub>29</sub> NO <sub>5</sub> Si  Anchoring reagent for light directed synthesis of E  1. McGall, G. et al. <i>J. Am. Chem. Soc.</i> <b>1997</b> , <i>119</i> , HYDROLYTIC SENSITIVITY: 7: reacts slowly with moi	, 5081. sture/water		40	50		
	[156214-80-1] SIT8102.0	HMIS: 2-2-1-X		10g	50g		
	SIT8192.0		400-500			1.09	1.4540 <sup>25</sup>
(CH20)36 CH3 (CH20)36 CH3	N-(TRIETHOXYSILYLPROPYL)-O-POLYETHYLENE - OXIDE URETHANE, 95% C <sub>10</sub> H <sub>22</sub> NO <sub>4</sub> SiO(CH <sub>2</sub> CH <sub>2</sub> O) <sub>4</sub> eH Hydrophilic surface modifier Forms PEGylated glass surfaces suitable for capi 1. Razunguzwa, T. et al. Anal. Chem. 2006, 78, 4		urethane) analog St				
(CH <sub>2</sub> O)Si CH <sub>3</sub> (CH <sub>2</sub> OCSHCH, CH <sub>3</sub> (CH <sub>3</sub> OCSHCH, CH <sub>3</sub>	OXIDE URETHANE, 95%  C <sub>10</sub> H <sub>22</sub> NO <sub>4</sub> SiO(CH <sub>2</sub> CH <sub>2</sub> O) <sub>4-6</sub> H  Hydrophilic surface modifier  Forms PEGylated glass surfaces suitable for capi	Viscosity: 75-125 cillary electrophoresis. 1326.	urethane) analog St				

## **Hydrophilic Silane Properties**

## Ionic-Charge Inducible

	name	MW	bp/mm (mp	<b>)</b>	D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{^{20}}$
	(2-N-BENZYLAMINOETHYL)-3-AMINOPROPYL- TRIMETHOXYSILANE hydrochloride, 90%	348.95 Flashpoint: 9	°C (48°F)		0.942	1.4104
CH-NH(CH <sub>3</sub> )-NH <sub>2</sub> (CH <sub>3</sub> )-SNOCH <sub>(3)</sub>	C <sub>15</sub> H <sub>28</sub> N <sub>2</sub> O <sub>3</sub> Si·HCl 50% in methanol Amber liquid HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	[623938-90-9] TSCA HMIS: 3-3-1-X		25g	100g		
	SIB1500.0					
CH2CH2OCH3	BIS(METHOXYETHYL)-3-TRIMETHOXYSILYLPROPYL- AMMONIUM CHLORIDE, 60% in methanol	331.91	1°C (E2°E)			
CI "HN CH2CH2CH2Si(OCH3))	C <sub>12</sub> H <sub>29</sub> NO <sub>5</sub> Si·HCl	Flashpoint: 1	110 (521)			
CH <sub>2</sub> CH <sub>2</sub> OCH <sub>3</sub>	Hydrophilic ammoniun salt; forms anti-fog surface films					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	HMIS: 3-4-1-X		25g			
(CH <sub>3</sub> O) <sub>3</sub> SiCH <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub>	SIB1835.0					
	BIS(3-TRIMETHOXYSILYLPROPYL)-N-METHYLAMINE $C_{13}H_{35}NO_6Si_2$	355.58	175 / 10		1.023	1.430
(CH <sub>2</sub> O) <sub>3</sub> SiCH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub>	C <sub>13</sub> H <sub>33</sub> NO <sub>6</sub> SI <sub>2</sub> See also SIB1828.0	Flashpoint: 1	06°C (223°F)			
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	[31024-70-1] HMIS: 2-1-0-X		25g	100g		
	SIC2263.0		- 5			
	CARBOXYETHYLSILANETRIOL, SODIUM SALT	196.14			1.170 25	
O OH	C <sub>3</sub> H <sub>6</sub> Na <sub>2</sub> O <sub>5</sub> Si 25% in water					
Na OCCH-CH-Si-O'Na	pH: 12 - 12.5					
OH	In combination w/ aminofunctional silanes forms amphoteric silicas.1					
- Oil	1. Han, L. et al. Chem. Mater. 2007, 19, 2860.					
	HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions					
	[18191-40-7] HMIS: 2-0-0-X		25g	100g		
	SIC2415.0					
CISO <sub>2</sub> —CH <sub>2</sub> CH <sub>2</sub> SiCl <sub>1</sub>	2-(4-CHLOROSULFONYLPHENYL)ETHYLTRICHLORO-	338.11			1.37	
	SILANE, 50% in methylene chloride					
Solid Phase Extraction	C <sub>8</sub> H <sub>8</sub> Cl <sub>4</sub> O <sub>2</sub> SSi	id condensation	producto			
(SPE) columns with	Contains 30% free sulfonic acid and small amounts of silyIsulfonic ac Employed in preparation of solid phase extraction columns	iu condensation	products			
benzenesulfonic acid	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so	olvents				
functional- ized silica	[79793-00-3] TSCA EC 279-267-2 HMIS: 4-2-2-X		25g	100g		
are utilized	SIC2415.4			_		
to analyze	2-(4-CHLOROSULFONYLPHENYL)ETHYLTRICHLORO-	338.11			1.08	
urine	SILANE, 50% in toluene					
samples for	$C_8H_8CI_4O_2SSi$					
amino acids	Contains 30% free sulfonic acid and small amounts of silyIsulfonic ac	id condensation	products			
and drugs	See also SIB1811.7					
of abuse.	HYDROLYTIC SENSITIVITY: 8: reacts rapidly with moisture, water, protic so [79793-00-3] TSCA EC 279-267-2 HMIS: 4-4-2-X	olvents	25g	100g		
*			23 <u>y</u>	1009		
	SIC2417.0	004.05			4 00 25	
	2-(4-CHLOROSULFONYLPHENYL)ETHYLTRIMETHOXY-	324.85			1.30 25	
	SILANE, 50% in methylene chloride  C <sub>11</sub> H <sub>17</sub> CIO <sub>5</sub> SSi  Amber color					
	Contains free sulfonic acid					
	Treated silica acts as etherification catalyst. <sup>1</sup>					
CISO <sub>2</sub> —CH <sub>2</sub> CH <sub>2</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	Reagent for surface initiated ATRP. <sup>2</sup>					
	Employed in mesostructured fuel-cell membranes. <sup>3</sup>					
	1. Sow, B. et al. <i>Microporous and Mesoporous Mat'ls</i> . <b>2005</b> , 79, 129.					
	2. Fukuda, J. et al. <i>Macromolecules</i> <b>2000</b> , 33, 2870.					
	3. Pereira, F. et al. Chem. Mater. 2008, 20, 1710.					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water					
	[126519-89-9] HMIS: 3-2-1-X		25g	100g		
	SID3392.0					
	N,N-DIDECYL-N-METHYL-N-(3-TRIMETHOXYSILYL-	510.32			0.863	1.4085
	PROPYL)AMMONIUM CHLORIDE, 40-42% in methanol	Flashpoint: 1	3°C (55°F)			
CH <sub>2</sub> CH <sub>2</sub> CH <sub>3</sub> CH <sub>3</sub> CH <sub>3</sub>	$C_{27}H_{60}CINO_3Si$					
спустух спустустуществуюсть	Contains 3-5% CI(CH <sub>2</sub> ) <sub>3</sub> Si(OMe) <sub>3</sub>					
LA TELEVISION TO THE STATE OF T	In combination with TEOS forms high pore volume xerogels w/ adsop	otive capacity.1				
	1. Markovitz, M. et al. <i>Langmuir</i> <b>2001</b> , <i>17</i> , 7085.					
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water		250			
	[68959-20-6] TSCA EC 273-403-4 HMIS: 3-4-0-X		25g			

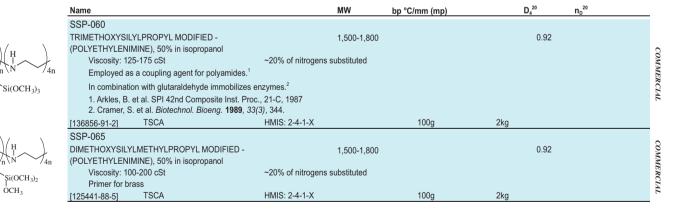
	name				MW	bp/mm (	mp)	$D_4^{20}$	$n_D^{20}$
,	SID3395.4								
OCH,CH; NCH2SI-OCH,CH3	(DIETHYLAMINOM C <sub>11</sub> H <sub>27</sub> NO <sub>3</sub> Si Catalyst for ne				249.43	74-6 / 3		0.9336 25	1.4142 25
OCH2CH1	,		7: reacts slowly with m	noisture/water					
	[15180-47-9]	TSCA-L	, , ,	HMIS: 2-2-1-X		25g			
	SID3395.6								
	(N,N-DIETHYLAMI	NOMETHYL)	TRIMETHOXYSILAN	NE	207.40				
NCH <sub>2</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	C <sub>8</sub> H <sub>21</sub> NO <sub>3</sub> Si								
H <sub>1</sub> CH <sub>2</sub>	Charge contro		ire silicone RTVs						
			7: reacts slowly with m	noisture/water					
	[67475-66-5]	TSCA-L	, ,	HMIS: 3-2-1-X		25g			
	SID3396.0								
	(N,N-DIETHYL-3-A	AMINOPROP	YL)TRIMETHOXYSIL	LANE	235.40	120 / 20		0.934	1.425
CH <sub>2</sub> NCH <sub>2</sub> CH <sub>2</sub> CH <sub>2</sub> SHOCH <sub>2</sub> )	C <sub>10</sub> H <sub>25</sub> NO <sub>3</sub> Si				Flashpoint: 1	00°C (212°F)			
CH, Mchachachashochan	Flovides silica		catalyst for 1,4-addition						
			nEur. J. <b>2009</b> , 15, 1 7: reacts slowly with m						
	[41051-80-3]	TSCA	EC 255-192-0	HMIS: 2-1-1-X		25g	100g		
	SIO6620.0		20 200 102 0			<u> </u>	1009		
	OCTADECYLDIME	THYL(3-TRI	METHOXYSILYL-		496.29			0.89	
		•	DE, 60% in methano	ıl	Flashpoint: 1	5°C (59°F)		5.00	
er. 191	C <sub>26</sub> H <sub>58</sub> CINO <sub>3</sub> Si		ntains 3-5% CI(CH <sub>2</sub> );			emperature: 230°C			
CI (II)	Orients liquid	crystals							
CH <sub>2</sub> -N = (CH <sub>2</sub> ) <sub>3</sub> Si(OCH <sub>3</sub> ) <sub>3</sub>	Employed as	-							
-(564E)	Provides an a		•		1				
				netic recording media	ı.'				
			le antimicrobial repor		E4.0	December 4000 - 005			
				rfaces; D. Leyden, D.					
	2. White, W. e See also SID33			aces; Leyden, D., Ed.;	, Guruon & Bread	л. 1900, p.10 <i>1</i> .			
			7: reacts slowly with m	noisture/water					
	[27668-52-6]	TSCA	EC 248-595-8	HMIS: 3-4-0-X		25g	2kg		
	SIP6926.2								
		IYL)THIOPRO	PYLTRIMETHOXY-		301.48	156-7 / 0.25		1.089	1.498
QCH <sub>2</sub>	SILANE	,							
N СИјенјаси <sub>њ</sub> а – осиј	$C_{13}H_{23}NO_3SSi$								
DCH <sub>0</sub>		SENSITIVITY:	7: reacts slowly with m						
	[29098-72-4]			HMIS: 3-2-1-X		10g			
ocii,	SIP6926.4								
		YL)THIOPRO	OPYLTRIMETHOXY-		301.48	160-2 / 0.2		1.09	1.5037
оповенья-осн.	2-(4-PYRIDYLETH								
dunisimis—one.	SILANE								
	SILANE C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi								
The second secon	SILANE C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi pKa: 4.8	∍ ligand for im	munoglobulin IgG se	eparation using hydror	ohobic charge inc	duction chromatography	(HCIC)		
The second secon	SILANE C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi pKa: 4.8 Immobilizable	•	munoglobulin IgG se 7: reacts slowly with m		phobic charge inc	duction chromatography	(HCIC)		
ben.	SILANE C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi pKa: 4.8 Immobilizable	•			phobic charge inc	duction chromatography	(HCIC)		
den.	SILANE  C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi  pKa: 4.8  Immobilizable  HYDROLYTIC	•		noisture/water	phobic charge inc		(HCIC)		
ben.	SILANE C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi pKa: 4.8 Immobilizable HYDROLYTIC [198567-47-4]	SENSITIVITY:	7: reacts slowly with m	noisture/water	phobic charge inc		(HCIC)	1.00	1.4624 <sup>24</sup>
don.	SILANE  C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> SSi pKa: 4.8 Immobilizable HYDROLYTIC:  [198567-47-4] SIP6928.0 2-(4-PYRIDYLETH' C <sub>13</sub> H <sub>23</sub> NO <sub>3</sub> Si	SENSITIVITY:	7: reacts slowly with m	noisture/water HMIS: 3-2-1-X	269.43	10g	(HCIC)	1.00	1.4624 <sup>24</sup>
don.	$\begin{array}{c} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$p\text{Ka: } 4.8$} \\ \text{$Immobilizable} \\ \text{$HYDROLYTIC:} \\ \hline \textbf{$[198567-47-4]$} \\ \text{SIP6928.0} \\ \text{$2-(4-PYRIDYLETH'} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{$Forms self-as} \end{array}$	SENSITIVITY: HYL)TRIETHO	7: reacts slowly with m  XYSILANE  Amber liquid ers which can be "nar	noisture/water	269.43	10g	(HCIC)	1.00	1.4624 <sup>24</sup>
den.	$\begin{array}{c} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$p\text{Ka: } 4.8$} \\ \text{$Immobilizable} \\ \text{$HYDROLYTIC:} \\ \hline \textbf{[198567-47-4]} \\ \text{SIP6928.0} \\ \text{$2\text{-}(4\text{-}PYRIDYLETH'} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{$Forms self-as} \\ \text{$1\text{.} Rosa, L. et} \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer tal. Mater. Let	7: reacts slowly with m	noisture/water HMIS: 3-2-1-X	269.43	10g	(HCIC)	1.00	1.4624 <sup>24</sup>
den.	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC} \\ \hline \underline{[198567-47-4]} \\ \text{SIP6928.0} \\ \text{$2\text{-(4-PYRIDYLETH'}$} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ \text{$1\text{.}$ Rosa, L. et} \\ \text{See also SIP69} \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. <i>Mater. Lei</i> 930.0	7: reacts slowly with m  XYSILANE  Amber liquid  ers which can be "nar  tt.2009, 63, 961.	noisture/water HMIS: 3-2-1-X	269.43	10g	(HCIC)	1.00	1.4624 <sup>24</sup>
ben,	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC} \\ \hline [198567-47-4] \\ \text{SIP6928.0} \\ \text{$2\text{-(4-PYRIDYLETH')}} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ \text{$1\text{. Rosa, L. et}} \\ \text{See also SIP69} \\ \text{HYDROLYTIC} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. <i>Mater. Lei</i> 930.0	7: reacts slowly with m  XYSILANE  Amber liquid ers which can be "nar	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii	269.43	10g 105 / 0.9	(HCIC)	1.00	1.4624 <sup>24</sup>
den.	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC} \\ \hline [198567-47-4] \\ \text{SIP6928.0} \\ \text{$2\text{-(4-PYRIDYLETH')}} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ \text{$1\text{. Rosa, L. et}} \\ \text{See also SIP69} \\ \text{HYDROLYTIC} \\ \hline [98299-74-2] \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. <i>Mater. Lei</i> 930.0	7: reacts slowly with m  XYSILANE  Amber liquid  ers which can be "nar  tt.2009, 63, 961.	noisture/water HMIS: 3-2-1-X	269.43	10g	(HCIC)	1.00	1.4624 <sup>24</sup>
ben,	$\begin{array}{l} \text{SILANE} \\ \text{$C_{19}$H}_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC} \\ \hline [198567-47-4] \\ \text{SIP6928.0} \\ \text{$2\text{-(4-PYRIDYLETH')}} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ \text{$1\text{. Rosa, L. et}} \\ \text{See also SIP69} \\ \text{HYDROLYTIC} \\ \hline [98299-74-2] \\ \text{SIP6930.0} \\ \end{array}$	SENSITIVITY: HYL)TRIETHO ssembled laye t al. Mater. Lei 930.0 SENSITIVITY:	7: reacts slowly with m  XYSILANE  Amber liquid  ars which can be "nar  tt.2009, 63, 961.  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9	(HCIC)		
ben,	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{SIP6928.0} \\ \text{$2-(4-\text{PYRIDYLETH'})} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{See also SIP69} \\ \text{HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{SIP6930.0} \\ \text{$2-(2-\text{PYRIDYLETH'})} \\ \text{$2-(2-\text{PYRIDYLETH'})} \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled laye t al. Mater. Lei 930.0 SENSITIVITY:	7: reacts slowly with m  XYSILANE Amber liquid  ers which can be "nar  tt.2009, 63, 961.  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9 10g	(HCIC)	1.00	1.4624 <sup>24</sup> 1.4755
den.	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC}. \\ \hline \underline{[198567-47-4]} \\ \text{SIP6928.0} \\ \text{$2-(4-PYRIDYLETH'} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{See also SIP66} \\ \text{HYDROLYTIC}. \\ \hline \underline{[98299-74-2]} \\ \text{SIP6930.0} \\ \text{$2-(2-PYRIDYLETH'} \\ \text{$2-(TRIMETHOXYSIL'} \\ \text{$2-(TRIMETHOXYSIL'} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled laye t al. Mater. Lei 930.0 SENSITIVITY:	7: reacts slowly with m  XYSILANE Amber liquid  ers which can be "nar  tt.2009, 63, 961.  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9	(HCIC)		
Сп <sub>2</sub> -сп <sub>2</sub> -si(осн <sub>2</sub> сн <sub>2</sub> ),	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{SIP6928.0} \\ \text{$2-(4-\text{PYRIDYLETH'})} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{See also SIP69} \\ \text{HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{SIP6930.0} \\ \text{$2-(2-\text{PYRIDYLETH'})} \\ \text{$2-(2-\text{PYRIDYLETH'})} \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. Mater. Let 930.0  SENSITIVITY:  HYL)TRIMETH LYLETHYL)PYF	7: reacts slowly with m  XYSILANE Amber liquid  ers which can be "nar  tt.2009, 63, 961.  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9 10g	(HCIC)		
Сп <sub>2</sub> -сп <sub>2</sub> -si(осн <sub>2</sub> сн <sub>2</sub> ),	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$p\text{Ka: 4.8}} \\ \text{$Immobilizable} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{$SIP6928.0} \\ \text{$2-(4-PYRIDYLETH'} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{$Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{$See also SIP66} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{$SIP6930.0} \\ \text{$2-(2-PYRIDYLETH'} \\ \text{$2-(TRIMETHOXYSIL'} \\ \text{$C_{10}$H}_{17}\text{NO}_3\text{Si} \\ \text{$See also SIP65} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. Mater. Let 930.0 SENSITIVITY:  HYL)TRIMETH LYLETHYL)PYR 928.0	7: reacts slowly with m  XYSILANE Amber liquid  ers which can be "nar  tt.2009, 63, 961.  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9 10g	(HCIC)		
Сп <sub>2</sub> -сп <sub>2</sub> -si(осн <sub>2</sub> сн <sub>2</sub> ),	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$p\text{Ka: 4.8}} \\ \text{$Immobilizable} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{$SIP6928.0} \\ \text{$2-(4-PYRIDYLETH'} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{$Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{$See also SIP66} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{$SIP6930.0} \\ \text{$2-(2-PYRIDYLETH'} \\ \text{$2-(TRIMETHOXYSIL'} \\ \text{$C_{10}$H}_{17}\text{NO}_3\text{Si} \\ \text{$See also SIP65} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. Mater. Let 930.0 SENSITIVITY:  HYL)TRIMETH LYLETHYL)PYR 928.0	7: reacts slowly with m  XYSILANE Amber liquid ers which can be "nar tt.2009, 63, 961.  7: reacts slowly with m  IOXYSILANE RIDINE	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9 10g	(HCIC)		
CH2-CH2-Si(OCH2CH3);	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$p\text{Ka: 4.8}} \\ \text{$Immobilizable} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{$SIP6928.0} \\ \text{$2-(4-PYRIDYLETH'} \\ \text{$C_{13}$H}_{23}\text{NO}_3\text{Si} \\ \text{$Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{$See also SIP66} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{$SIP6930.0} \\ \text{$2-(2-PYRIDYLETH'} \\ \text{$2-(TRIMETHOXYSIL'} \\ \text{$C_{10}$H}_{17}\text{NO}_3\text{Si} \\ \text{$See also SIP66} \\ \text{$HYDROLYTIC:} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. Mater. Let 930.0 SENSITIVITY:  HYL)TRIMETH LYLETHYL)PYR 928.0	7: reacts slowly with m  XYSILANE Amber liquid ers which can be "nar tt.2009, 63, 961.  7: reacts slowly with m  IOXYSILANE RIDINE	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9 10g 105 / 0.3 110°C (>230°F)			
CH2-CH2-Si(OCH2CH3);	$\begin{array}{l} \text{SILANE} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$p\text{Ka: 4.8}} \\ \text{$Immobilizable} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{$SIP6928.0} \\ \text{$2-(4-PYRIDYLETH'} \\ \text{$C_{13}$H_{23}$NO_3$Si} \\ \text{$Forms self-as} \\ \text{$1.$ Rosa, L. et} \\ \text{$See also SIP66} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{$SIP6930.0} \\ \text{$2-(2-PYRIDYLETH'} \\ \text{$2-(7RIMETHOXYSIL'} \\ \text{$C_{10}$H_{17}$NO_3$Si} \\ \text{$See also SIP66} \\ \text{$HYDROLYTIC:} \\ \hline \underline{[27326-65-4]} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled laye t al. <i>Mater. Lei</i> 930.0 SENSITIVITY:  HYL)TRIMETH  LYLETHYL)PYR 928.0 SENSITIVITY:	7: reacts slowly with m  XYSILANE Amber liquid ers which can be "nar ft. 2009, 63, 961.  7: reacts slowly with m  IOXYSILANE RIDINE  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup>	10g 105 / 0.9 10g 105 / 0.3 110°C (>230°F)			
CH <sub>2</sub> -CH <sub>2</sub> -Si(OCH <sub>2</sub> CH <sub>3</sub> ) <sub>3</sub>	$\begin{array}{l} \text{SILANE} \\ C_{13}H_{23}\text{NO}_3\text{SSi} \\ \text{pKa: 4.8} \\ \text{Immobilizable} \\ \text{HYDROLYTIC:} \\ \hline \underline{[198567-47-4]} \\ \text{SIP6928.0} \\ 2-(4-\text{PYRIDYLETH'} \\ C_{13}H_{23}\text{NO}_3\text{Si} \\ \text{Forms self-as} \\ 1. \text{Rosa, L. et} \\ \text{See also SIP66} \\ \text{HYDROLYTIC:} \\ \hline \underline{[98299-74-2]} \\ \text{SIP6930.0} \\ 2-(2-\text{PYRIDYLETH'} \\ 2-(\text{TRIMETHOXYSIL:} \\ C_{10}H_{17}\text{NO}_3\text{Si} \\ \text{See also SIP66} \\ \text{HYDROLYTIC:} \\ \hline \underline{[27326-65-4]} \\ \text{SIT8157.0} \\ \end{array}$	SENSITIVITY:  HYL)TRIETHO  ssembled laye t al. <i>Mater. Lei</i> 930.0 SENSITIVITY:  HYL)TRIMETH  LYLETHYL)PYR 928.0 SENSITIVITY:	7: reacts slowly with m  XYSILANE Amber liquid ers which can be "nar ft. 2009, 63, 961.  7: reacts slowly with m  IOXYSILANE RIDINE  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup> 227.33 Flashpoint: >	10g 105 / 0.9 10g 105 / 0.3 110°C (>230°F)	50g		
CH2-CH2-Si(OCH2CH3)i	eq:substitute of the control of the contro	SENSITIVITY:  HYL)TRIETHO  ssembled layer t al. Mater. Let 930.0 SENSITIVITY:  HYL)TRIMETH LYLETHYL)PYR 928.0 SENSITIVITY:  SENSITIVITY:  SENSITIVITY:	7: reacts slowly with m  OXYSILANE Amber liquid ers which can be "nar ett. 2009, 63, 961.  7: reacts slowly with m  OXYSILANE RIDINE  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup> 227.33 Flashpoint: >	10g 105 / 0.9 10g 105 / 0.3 110°C (>230°F)	50g		
CH2-CH2-Si(OCH3CH3);  CH2-CH2-Si(OCH3CH3);	SILANE $C_{13}H_{23}NO_3SSi\\pKa: 4.8\\Immobilizable\\HYDROLYTIC: \\[198567-47-4]\\SIP6928.0\\2-(4-PYRIDYLETH'C_{13}H_{23}NO_3Si\\Forms self-as 1. Rosa, L. et See also SIP69\\HYDROLYTIC: \\[98299-74-2]\\SIP6930.0\\2-(2-PYRIDYLETH'C_{17}NO_3Si)\\See also SIP69\\HYDROLYTIC: \\[2729-74-2]\\SIP6930.0\\2-(2-PYRIDYLETH'C_{10}H_{17}NO_3Si)\\See also SIP69\\HYDROLYTIC: \\[27326-65-4]\\SIT8157.0\\2-[2-(TRICHLOROSC_{7}H_{8}Cl_{3}NSi)\\Fuming solid, See also SIP69$	SENSITIVITY:  HYL)TRIETHO  SSEMBIED layer  t al. Mater. Let  930.0  SENSITIVITY:  HYL)TRIMETH  LYLETHYL)PYF  928.0  SENSITIVITY:  SENSITIVITY:  SILYL)ETHYL  , moisture sen  930.0	7: reacts slowly with m  XYSILANE Amber liquid ers which can be "nar tt.2009, 63, 961.  7: reacts slowly with m  ROXYSILANE RIDINE  7: reacts slowly with m	noisture/water HMIS: 3-2-1-X  no-shaved" by scannii noisture/water HMIS: 3-2-1-X	269.43 ng AFM. <sup>1</sup> 227.33 Flashpoint: >	10g 105 / 0.9 10g 105 / 0.3 110°C (>230°F)	50g		

STRIESO	CHAPACITY   Continue		name			MW	bp/mm (mp)		$D_4^{20}$	$n_{\scriptscriptstyle D}^{\scriptscriptstyle 20}$
TREATMENT   TREA	Procedure   Proc	CH2CH2SiCI3	4-[2-(TRICHLOROSILYL)  C <sub>7</sub> H <sub>8</sub> Cl <sub>3</sub> NSi Hazy liquid; extreme Employed in polypyr 1. Paulson, S. et al.	15-20% in toluend ly moisture sensitive idine self-assembled mono J. Chem. Soc., Chem. Com	layers. <sup>1</sup> nmun. <b>1992</b> , 21, 1615	Flashpoint: 4°0	C (39°F)		0.93	
STR875   S	STREET, STRE					Ivents				
AG-TREETHOXYSILT/PROPYL/S-S-DHYDRO-	ACTION   Control   Contr			A EC 241-138-3	HMIS: 3-4-1-X		25g	100g		
Utilized in HPLC of metal chiedates   Fermi protron viscancy conducting polymers would-married to by sol gield   Ligand for indicated reporting of silica and chymothypain transition state analog. *	Utilized in HPLC of metal cheites."	The second secon	$\begin{array}{c} \text{N-(3-TRIETHOXYSILYLP}\\ \text{IMIDAZOLE}\\ \text{3-(2-IMIDAZOLIN-1-YL)PRO}\\ \text{C}_{12}\text{H}_{26}\text{N}_2\text{O}_3\text{Si}\\ \text{Viscosity:} \ 5 \text{ cSt.} \end{array}$	PYLTRIETHOXYSILANE, IME					1.005	1.452
		55-949	Utilized in HPLC of r Forms proton vacan Ligand for molecular 1. Suzuki, T. et al. C. 2. De Zea Bermudez 3. Markowitz, M. et a	metal chelates. <sup>1</sup> cy conducting polymers w/s imprinting of silica with chy hem. Lett. <b>1994</b> , 881. z, V. et al. Sol-Gel Optics II, al. Langmuir <b>2000</b> , 16, 1758	sulfonamides by sol-ga motrypsin transition s SPIE Proc. 1992, 17:	tate analog.3				
TRIETHOXYSILY PROPYLIPOLYETHYLENE- OXYPROPOLYPOTASSIUM SULFATE, 50% in ehanol CxHx,CHx,CHx,CCHx,CHx,OC,SSI OXYPROPOLYPOTASSIUM SULFATE, 50% in ehanol CxHx,CHx,CHx,CCHx,CHx,OC,SSI OXYPROPOLYPOTASSIUM SULFATE, 50% in ehanol CxHx,CHx,CHx,CCHx,CHx,OC,SSI OXYPROPOLYPOTASSIUM SULFATE, 50% in ehanol CxHx,SICHI OXYPROPOLYPOT	TRIETHOX/SILVTROPYLIPOLYETHYLENE: 823.01  OXYRPOPYLIPOLASSIUM SULFATE, 50% in ethanol Codek(KOLSS) OXYRPOPYLIPOLASSIUM SULFATE, 50% in ethanol Codek(KOLSS) OXYRPOPYLIPOLASSIUM SULFATE, 50% in ethanol Codek(KOLSS) OXYRPOPYLIPOLASSIUM SULFATE, 50% in ethanol Codek(KOLSS) OXYRPOPYLIPOLASSIUM SULFATE, 50% in ethanol Codek(KOLSS) OXYRPOPYLIPOLASSIUM SULFATE, 50% in ethanol Codek(KOLSS) STR3878.3 3-TRIHYDROXYSILV1,1-PROPANESULFONC ACID 202.26 1.12 Codek(KOLSS) STR3878.3 3-TRIHYDROXYSILV1,1-PROPANESULFONC ACID 202.26 1.12 Employed in preparation of nearoscale ionic silicas.¹ Employed in preparation of nearoscale ionic silicas.¹ I code in the silica squares solutions of						25g	100g		2kg
MINERAL   MAIN   MINERAL   MAIN   MINERAL   MAIN   MINERAL   MAIN   MINERAL   MINERA	MORCH   SHORT   SENSITIVITY 7: reacts slowly with moisture/water   HIMIS: 2-2-1-X   2.5g	0	TRIETHOXYSILYLPROP¹ OXY)PROPYLPOTASSIU $C_{32}H_{67}KO_{17}SSi$ $OC_2H_5$	•	ol	823.01				
HYDROLYTIC SENSITIVITY: 7: reads slowly with moisture/water	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water   HMIS: 22-1-X   2.5g	$-SCH_2CH_2CH_2O(CH_2CH_2O)_6$	9							
MMIS: 2-2-1-X   2.5g	HMIS: 2-2-1-X   2.5g	Ö	OC <sub>2</sub> H <sub>5</sub>							
SIT8378.3   3-(TRIHYDROXYSILYL)-1-PROPANESULFONIC ACID   202.26   1.12	SIT8378.3   3-(TRINYDROYSILYL)-1-PROPANESULFONIC ACID   202.26   1.12		HYDROLYTIC SENSIT	ΓΙVΙΤΥ: 7: reacts slowly with m	oisture/water					
ATRIHYDROXYSILV1	STRINDENCYSILYL)-1-PROPANESULFONIC ACID   202.26   1.12				HMIS: 2-2-1-X		2.5g			
C.H., O.SSI 30-35% in water pH : <1	CH_O_SSI 30-35% in water pH: <1		SIT8378.3							
HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions   TSCA	HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions   Toda	IOSCH2CH2CH2Si(OH)3	$C_3H_{10}O_6SSi$ pH: <1	30-35% in water		202.26			1.12	
3-TRIHYDROXYSILYLPROPYLMETHYLPHOSPHATE, - 238.18	3-TRIHYDROXYSILYLPROPYLMETHYLPHOSPHATE, 238.18 1.25  SODIUM SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 42% in water CHINNON SALT, 36% in wa		HYDROLYTIC SENSIT	FIVITY: 0: forms stable aqueou	us solutions		25g	100g		
SODIUM SALT, 42% in water C <sub>Lf-1/2</sub> Na <sub>2</sub> O <sub>2</sub> PSi Contains 4-5% methanol, sodium methylphosphonate HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions [84962-98-1] TSCA EC 284-799-3 HMIS: 1-2-0-X 100g 500g SIT8395.0 N.(TRIMETHOXYSILYLETHYL)BENZYL-N.N.N- 333.93 0.966 Flashpoint: 25°C (77°F) C <sub>15</sub> H <sub>22</sub> CINO <sub>2</sub> Si Candidate for exchange resins and extraction phases HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture-water HMIS: 3-3-1-X 25g Flashpoint: 137°C (279°F) C <sub>10</sub> H <sub>22</sub> N <sub>2</sub> O <sub>2</sub> Si C <sub>10</sub> H <sub>22</sub> N <sub>2</sub> O <sub>2</sub> Si TRIAMINE: 95% Flashpoint: 137°C (279°F) TOXICITY: oral rat, LD50: >2,000 mg/kg yc of treated surface: 37.5 mN/m Hardener, coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture-water [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X 100g 2kg SIT8402.0 N.(TRIMETHOXYSILYLPROPYL)EITHYLENEDIAMINE, 462.42 1.26 TRIAMINE: 126	SODIUM SALT, 42% in water		SIT8378.5					_	_	
HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions  [84962-98-1] TSCA EC 284-799-3 HMIS: 1-2-0-X 100g 500g  SIT8395.0  N-(TRIMETHOXYSILYLETHYL.)BENZYL-N.N.N- 333.93 0.966  TRIMETHYLAMMONIUM CHLORIDE, 60% in methanol Flashpoint: 25°C (77°F)  C1 <sub>5</sub> H <sub>26</sub> CINO <sub>5</sub> Si  Candidate for exchange resins and extraction phases HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 3-3-1-X 25g  SIT8398.0  (G1-01-11-11-11-11-11-11-11-11-11-11-11-11	HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions  [84962-96-1] TSCA EC 284-799-3 HMIS: 1-2-0-X 100g 500g  SIT8395.0  N-(TRIMETHOXYSILYLETHYL.)BENZYL-N,N,N-333.93 0.966  TRIMETHYLAMMONIUM CHLORIDE, 60% in methanol Flashpoint: 25°C (77°F)  C1 <sub>5</sub> H <sub>26</sub> CINO <sub>5</sub> Si  Candidate for exchange resins and extraction phases HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water HMIS: 3-3-1-X 25g  SIT8398.0  (G10 Site 19 Site		SODIUM SALT, 42% in was $C_4H_{12}NaO_6PSi$	ater			°C (174°F)		1.25	
84962-98-1  TSCA   EC 284-799-3   HMIS: 1-2-0-X   100g   500g	R4962-98-1  TSCA   EC 284-799-3   HMIS: 1-2-0-X   100g   500g									
N-(TRIMETHOXYSILYLETHYL)BENZYL-N,N,N- TRIMIETHYLAMMONIUM CHLORIDE, 60% in methanol Ci <sub>tit</sub> H <sub>128</sub> CINO,Si  Candidate for exchange resins and extraction phases HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water HMIS: 3-3-1-X  SIT8398.0 (3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95% Cu-ll-27,NO,Si Vo of treated surface: 37.5 mN/m Hardener, coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water TSIA130-1] TSCA EC 252-390-9 HMIS: 3-1-1-X  TRIAGETIC ACID, TRISODIUM SALT, 35% in water Cu-ll-27,Na <sub>2</sub> O,Si ESsentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	N-(TRIMETHOXYSILYLETHYL)BENZYL-N,N-N- TRIMIETHYLAMMONIUM CHLORIDE, 60% in methanol C <sub>1it</sub> H <sub>728</sub> CINO <sub>3</sub> Si Candidate for exchange resins and extraction phases HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water HMIS: 3-3-1-X  SIT8398.0 (3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95% C <sub>10</sub> H <sub>727</sub> N <sub>Q</sub> O,Si V <sub>2</sub> Coft-P <sub>27</sub> N <sub>Q</sub> O,Si V <sub>2</sub> Coft-P <sub>27</sub> N <sub>Q</sub> O,Si V <sub>3</sub> Coft-P <sub>37</sub> N <sub>Q</sub> O,Si V <sub>4</sub> Coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X  100g 2kg  TRIACETIC ACID, TRISODIUM SALT, 35% in water C <sub>114</sub> H <sub>28</sub> N <sub>Q</sub> N <sub>Q</sub> Si Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions						100g	500g		
HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 3-3-1-X  25g  SIT8398.0  (3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95% Flashpoint: 137°C (279°F) C₁₀H₂ʔ/N₃O₃Si γc of treated surface: 37.5 mN/m Hardener, coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X  100g 2kg  SIT8402.0 N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - TRIACETIC ACID, TRISODIUM SALT, 35% in water C₁₄H₂₅N₂Na₃O₃Si Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  HMIS: 3-3-1-X  25g  SIT8398.0  (3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95%  C10H <sub>27</sub> N <sub>3</sub> O <sub>3</sub> Si  yc of treated surface: 37.5 mN/m  Hardener, coupling agent for epoxies  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [35141-30-1]  TSCA  EC 252-390-9  HMIS: 3-1-1-X  100g  2kg  SIT8402.0  N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, -  TRIACETIC ACID, TRISODIUM SALT, 35% in water  C14H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>5</sub> Si  Essentially silanetriol, contains NaCl  Chelates metal ions  HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	et CH <sup>2</sup> CH <sup>2</sup> CH <sup>2</sup> SROCH <sup>2</sup> N	N-(TRIMETHOXYSILYLE TRIMETHYLAMMONIUM $C_{15}H_{28}CINO_3Si$	CHLORIDE, 60% in metha			°C (77°F)		0.966	
SIT8398.0	SIT8398.0									
SIT8398.0  (3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95% C <sub>10</sub> H <sub>27</sub> N <sub>3</sub> O <sub>3</sub> Si VC of treated surface: 37.5 mN/m Hardener, coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X 100g 2kg  SIT8402.0 N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42 1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>2</sub> Si Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	SIT8398.0		HIDROLI IIC SENSI	i ivi i i . i . i eacis siowiy with m			25a			
(3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95% C <sub>10</sub> H <sub>27</sub> N <sub>3</sub> O <sub>3</sub> Si VC of treated surface: 37.5 mN/m Hardener, coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X 100g 2kg  SIT8402.0 N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42 1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>3</sub> Si Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	(3-TRIMETHOXYSILYLPROPYL)DIETHYLENE- TRIAMINE, 95% C10H27N3O3Si TOXICITY: oral rat, LD50: >2,000 mg/kg  yc of treated surface: 37.5 mN/m Hardener, coupling agent for epoxies HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X 100g 2kg  SIT8402.0 N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42 1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water C14P3N3N3O3Si Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions		SIT8398 0		1 IIVII O. 0-0-1-X		209			
Hardener, coupling agent for epoxies  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X 100g 2kg  SIT8402.0  N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42 1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water  C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>9</sub> Si  Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	Hardener, coupling agent for epoxies  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [35141-30-1] TSCA EC 252-390-9 HMIS: 3-1-1-X 100g 2kg  SIT8402.0  N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42 1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water  C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>9</sub> Si  Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	CH <sup>2</sup>	(3-TRIMETHOXYSILYLPF TRIAMINE, 95% $C_{10}H_{27}N_3O_3Si$			Flashpoint: 13	7°C (279°F)		1.030	1.4590
SIT8402.0  N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42  1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water  C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>9</sub> Si  Essentially silanetriol, contains NaCl  Chelates metal ions  HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	SIT8402.0  N-(TRIMETHOXYSILYLPROPYL)ETHYLENEDIAMINE, - 462.42  1.26  TRIACETIC ACID, TRISODIUM SALT, 35% in water  C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>9</sub> Si  Essentially silanetriol, contains NaCl  Chelates metal ions  HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	(ento)isient	Hardener, coupling a	agent for epoxies FIVITY: 7: reacts slowly with m			100g	2kg		
TRIACETIC ACID, TRISODIUM SALT, 35% in water  C <sub>14</sub> H <sub>25</sub> N <sub>2</sub> Na <sub>3</sub> O <sub>9</sub> Si  Essentially silanetriol, contains NaCl  Chelates metal ions  HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	TRIACETIC ACID, TRISODIUM SALT, 35% in water $C_{14}H_{25}N_2Na_3O_9Si$ Essentially silanetriol, contains NaCl Chelates metal ions HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions		SIT8402.0					_		
HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	OOCCH <sup>2</sup> CH <sup>2</sup> CH <sup>2</sup> COO, NI,	$\begin{aligned} &\text{N-(TRIMETHOXYSILYLPI)} \\ &\text{TRIACETIC ACID, TRISO} \\ &\text{C}_{14}\text{H}_{25}\text{N}_2\text{Na}_3\text{O}_9\text{Si} \\ &\text{Essentially silanetrio} \end{aligned}$	DIUM SALT, 35% in water	NE, -	462.42			1.26	
		transferred		FIVITY: (): forms stable across	is solutions					
1128850-89-51	[12000 00 0] 1000 1000 1000 1000 1000						25a	100a		

				0 01000, 11	
	SIT8405.0 N-(TRIMETHOXYSILYLPROPYL)ISOTHIOURONIUM -	274.84	1.190	1.441	_
$\frac{H_2N}{c} = s - cH_2CH_2CH_3s_0CCH_3s_3$	CHLORIDE, 50% in water TRIHYDROXYPROPYLCARBAMIDOTHIOIC ACID HYDROCHLORIDE C <sub>7</sub> H <sub>19</sub> CIN <sub>2</sub> O <sub>3</sub> SSi Antimicrobial activity reported Essentially silanetriol HYDROLYTIC SENSITIVITY: 0: forms stable aqueous solutions	pH: 6			
	[84682-36-0] TSCA EC 283-599-3 HMIS: 2-0-0-X	25g			
$C_{i}H_{i} = \sum_{C_{i}H_{i}}^{C_{i}H_{i}} CH_{i}CH_{i}CH_{2}Si(OCH_{i})_{i}$	SIT8412.0 N-TRIMETHOXYSILYLPROPYL-N,N,N-TRI-n-BUTYL- AMMONIUM BROMIDE, 50% in methanol C <sub>16</sub> H <sub>42</sub> BrNO <sub>3</sub> Si Immobilizable phase transfer catalyst	428.52 Flashpoint: 11°C (52°F)	0.92		
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water HMIS: 3-4-1-X	25g			
$C^{\dagger}H^{0} = \sum_{\substack{C^{\dagger}H^{0} \\ C^{\dagger}}}^{C^{\dagger}H^{0}} CH^{2}CH^{2}CH^{2}SHOCH^{3}S$	SIT8414.0  N-TRIMETHOXYSILYLPROPYL-N,N,N-TRI-n-BUTYL- AMMONIUM CHLORIDE, 50% in methanol  C <sub>16</sub> H <sub>42</sub> CINO <sub>3</sub> Si  Contains 3-5% chloropropyltrimethoxysilane and Bu <sub>3</sub> NH*CI	384.08 Flashpoint: 11°C (52°F)	0.88		
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water HMIS: 3-4-1-X	25g			
	SIT8415.0 N-TRIMETHOXYSILYLPROPYL-N,N,N-TRIMETHYL- AMMONIUM CHLORIDE, 50% in methanol	257.83 Flashpoint: 16°C (61°F)	0.927	1.3966	
cn* n²c-2,—cn²cn²cn²sкосnэч cn²c cn²cn²cn²sкоснэч	N,N,N-TRIMETHYL-3-(TRIMETHOXYSILYL)-1-PROPANAMINIUM CHLORIDE  C <sub>B</sub> H <sub>24</sub> CINO <sub>3</sub> Si  Employed for bonded chromatographic phases  Anti-static agent  Used to treat glass substrates employed in electroblotting  Prevents contact electrification. <sup>1</sup> 1. Thomas, S. et al. J. Am. Chem. Soc. 2009, 131, 8746.  See also SIT8395.0  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water				COMMERCIAL
	[35141-36-7] TSCA EC 252-393-5 HMIS: 2-4-1-X	25g	2kg		
	SIT8422.0				
$C_{2}H_{0} \! \rightarrow \! \! \underbrace{\overset{C_{2}H_{0}}{\overset{C}{\sim}} \overset{G}{\cap}_{H_{0}}}_{CH_{2}(CH_{2})_{10}} S_{NOCH_{2}(t_{1})}$	N-TRIMETHOXYSILYLUNDECYL-N,N,N-TRI-n-BUTYL-AMMONIUM BROMIDE, 25% in dimethylformamide $C_{26}H_{58}BrNO_3Si\\Immobilizable phase transfer catalyst$	540.74 Flashpoint: 59°C (138°F)	0.965 <sup>25</sup>	1.443	
	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	0.5			
	HMIS: 3-4-1-X	25g			

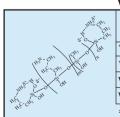
#### Polymeric Hydrophilic Silanes

Polymeric Amine



### Water-borne Aminoalkyl Silsesquioxane Oligomers

**TSCA** 



	Functional	N	Molecular	Weight %	Specific				
Code	Group	Mole %	Weight	in solution	Gravity	Viscosity	pН	Price/100g	3kg
WSA-7011	Aminopropyl	65-75	250-500	25-28	1.10	5-15	10-10.5		
WSA-9911*	Aminopropyl	100	270-550	22-25	1.06	5-15	10-10.5		
WSA-7021	Aminoethylaminopropyl	65-75	370-650	25-28	1.10	5-10	10-11		
WSAV-6511**	Aminopropyl, vinyl	60-65	250-500	25-28	1.11	3-10	10-11		
*CAS [29159-3	37-3] **[207308-27-8]								

Aqueous exposure of treated surfaces converts Epoxy-Silanes to Hydrophilic-Diols

## **Epoxy Functional Silanes Epoxy Functional Silanes - Trialkoxy**

	name	MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	<b>n</b> <sub>D</sub> <sup>20</sup>	
CH.CH <sub>2</sub> Si(OC,4t <sub>0</sub> )	SIE4668.0 2-(3,4-EPOXYCYCLOHEXYL)ETHYLTRIETHOXYSILANE C <sub>14</sub> H <sub>28</sub> O <sub>4</sub> Si	288.46 Flashpoint:	114-7 / 0.4 104°C (219°F)		1.015	1.4455	COMMENCIAL
	Adhesion promoter for water-borne coatings on alkaline substrates HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water [10217-34-2] TSCA HMIS: 2-1-1-X		25g	100g		2kg	
спуснумосну	SIE4670.0  2-(3,4-EPOXYCYCLOHEXYL)ETHYLTRIMETHOXY- SILANE  C <sub>11</sub> H <sub>22</sub> O <sub>4</sub> Si  Viscosity: 5.2 cSt  Coefficient of thermal expansion: 0.8 x 10 <sup>-3</sup> Vapor pressure, 152': 10 mm  Ring epoxide more reactive than glycidoxypropyl systems  UV initiated polymerization of epoxy group with weak acid donors  Forms UV-curable coating resins by controlled hydrolysis. <sup>1</sup>	TOXICITY: γc of treated	95-7 / 0.25 146°C (295°F) oral rat, LD50: 12,300 mg/kg   surfaces: 39.5 mN/m ting surface: 317 m²/g		1.065	1.4490	COMMENCIAL
	Used to make epoxy-organosilica particles w/ high positive Zeta pot 1. Just, O. et al. Mater. Res. Soc. Symp. Proc. 1996, 415, 111. 2. Nakamura, M. and Ishimura, K. Langmuir 2008, 24, 12228.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [3388-04-3] TSCA EC 222-217-1 HMIS: 3-1-1-X	ential. <sup>2</sup>	100g	2kg		18kg \$	
.о с−сисп₁сп₁сп₁сп₃кос₁п,	HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	262.42 Flashpoint: 9	115-9 / 1.5 99°C (210°F)		0.960 25	1.4254 <sup>25</sup>	
cuedecu, cuencu, cuence-sericu, ocueu,	IMIS: 3-2-1-X   SIG5839.0   SIG5839.0   (3-GLYCIDOXYPROPYL)TRIETHOXYSILANE   C <sub>12</sub> H <sub>28</sub> O <sub>5</sub> Si   Coupling agent for latex polymers   HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	278.42 Flashpoint: <sup>2</sup>	10g 124 / 3 144°C (291°F)		1.00	1.425	COMMENCIAL
18-115-111	[2602-34-8] TSCA EC 220-011-6 HMIS: 3-1-1-X SIG5840.0 (3-GLYCIDOXYPROPYL)TRIMETHOXYSILANE	236.34	25g 120 / 2 (<-70	100g	1.070	2kg 1.4290	F
CH,CH,CH,  CH,CH,CH,  CH,O-SI-OCH,  OCH,	3-(2,3-EPOXYPROPOXY)PROPYLTRIMETHOXYSILANE GLYMO, GPTMS, A-187  C <sub>9</sub> H <sub>20</sub> O <sub>5</sub> Si  Viscosity: 3.2 cSt  Component in abrasion resistant coatings for plastic optics  Coupling agent for epoxy composites employed in electronic "chip"  Component in aluminum metal bonding adhesives  Used to prepare epoxy-containing hybrid organic-inorganic material  1. Innocenzi, P. et al. Chem. Mater. 1999, 11, 1672.  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	TOXICITY: Surface tens Specific wet encapsulation	135°C (276°F) oral rat, LD50: 8,400 mg/kg sion: 38.5 mN/m ting surface: 331 m²/g	Y		*	COMMERCIAL
,0,	[2530-83-8] TSCA EC 219-784-2 HMIS: 3-1-1-X SIG5840.1		100g	2kg		18kg	
cuton-er-ocut	(3-GLYCIDOXYPROPYL)TRIMETHOXYSILANE 99+%  C <sub>9</sub> H <sub>29</sub> O <sub>5</sub> Si  Low fluorescence grade for high-throughput screening  HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water  [2530-83-8] TSCA EC 219-784-2 HMIS: 3-1-1-X	236.34 Flashpoint:	120 / 2 (<-70 135°C (276°F) 25q	in fluoropolym	1.070	1.4290	
	Epoxy Functional Silanes - Dialkoxy SIG5832.0		239	пт пиогорогут	er boule		
carcu-cas carcu-cas	(3-GLYCIDOXYPROPYL)METHYLDIETHOXYSILANE  C <sub>11</sub> H <sub>24</sub> O <sub>4</sub> Si  Viscosity: 3.0 cSt  Employed in scratch resistant coatings for eye glasses  Coupling agent for latex systems with reduced tendancy to gel comply hydroclyTIC SENSITIVITY: 7: reacts slowly with moisture/water  [2897-60-1] TSCA EC 220-780-8 HMIS: 2-1-1-X	TOXICITY: o	122-6 / 5 122°C (252°F) oral rat, LD50: >2,000 mg/kg 0.0	100g	0.978 <sup>25</sup>	1.431 2kg	COMMENCIAL
original cut	SIG5836.0 (3-GLYCIDOXYPROPYL)METHYLDIMETHOXYSILANE C <sub>9</sub> H <sub>20</sub> O <sub>4</sub> Si Relative hydrolysis rate vs. SIG5840.0: 7.5:1 HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	220.34 Flashpoint:	100 / 4 105°C (221°F)	1919	1.02	1.431 <sup>25</sup>	
	[65799-47-5] TSCA EC 265-929-8 HMIS: 3-1-1-X  Epoxy Functional Silanes - Monoalkoxy		25g	100g			
chailen, chailen, chien,	SIG5825.0 (3-GLYCIDOXYPROPYL)DIMETHYLETHOXYSILANE C <sub>10</sub> H <sub>22</sub> O <sub>3</sub> Si HYDROLYTIC SENSITIVITY: 7: reacts slowly with moisture/water	218.37 Flashpoint: 8	100 / 3 37°C (189°F)		0.950	1.4337 <sup>25</sup>	
oc <sub>s</sub> u <sub>s</sub>	[17963-04-1] TSCA EC 241-889-7 HMIS: 3-2-1-X		10g	50g			

## Silyl Hydrides

Silyl Hydrides are a distinct class of silanes that behave and react very differently than conventional silane coupling agents. Their application is limited to deposition on metals (see discussion on p. 17). They liberate hydrogen on reaction and should be handled a with appropriate caution.

	name	MW	bp/mm (mp)		D <sub>4</sub> <sup>20</sup>	$n_{\scriptscriptstyle D}^{_{\scriptscriptstyle 20}}$
	SID4629.6					
	DODECYLSILANE	200.44	80 / 7		0.7753	1.4380 <sup>25</sup>
3(CH <sub>2</sub> )10CH <sub>2</sub> SiH <sub>3</sub>	C <sub>12</sub> H <sub>28</sub> Si					
	Forms SAMs on gold and titanium surfaces HYDROLYTIC SENSITIVITY: 4: no reaction with water under neutral condition	ons				
	[872-19-5] HMIS: 2-2-1-X		10g			
	SIO6635.0					
	n-OCTADECYLSILANE	284.60	195 / 15 (29)		0.794	
H	C <sub>18</sub> H <sub>40</sub> Si Contains 4-6% C <sub>18</sub> isomers	Flashpoint:	>110°C (>230°F)			
(CH <sub>2</sub> ) <sub>16</sub> CH <sub>2</sub> =\$i=H	Forms self-assembled monolayers on titanium. <sup>1</sup>					
н	Reacts onto a gold surface to form monolayers of long alkyl chains. <sup>2</sup> 1. Fadea, A. et al. <i>J. Am. Chem. Soc.</i> <b>1989</b> , <i>121</i> , 12184. 2. Owens, T. M. et al. <i>J. Am. Chem. Soc.</i> <b>2002</b> , <i>124</i> , 6800. HYDROLYTIC SENSITIVITY: 3: reacts with aqueous base					
	[18623-11-5] TSCA EC 242-453-9 HMIS: 2-1-1-X		25g	100g		
	SIT8173.0		-			
30	TRIDECAFLUORO-1,1,2,2-TETRAHYDROOCTYL)SILANE	378.21	75 / 25		1.446	1.318
CF55CH5CH5-Si-H	C <sub>8</sub> H <sub>7</sub> F <sub>13</sub> Si					
	Provides vapor-phase hydrophobic surfaces on titanium, gold, silicon					
3H.7	HYDROLYTIC SENSITIVITY: 3: reacts with aqueous base					
	[469904-32-3] HMIS: 3-3-1-X		10g			
	SIU9048.0					
H	10-UNDECENYLSILANE	184.40			0.768 25	1.4415 <sup>25</sup>
=CH(CH <sub>2</sub> ) <sub>8</sub> CH <sub>2</sub> \$i-H	C <sub>11</sub> H <sub>24</sub> Si					
Н	Forms self-assembled monolayers on gold					
7.60	HYDROLYTIC SENSITIVITY: 3: reacts with aqueous base					
	HMIS: 2-3-1-X		2.5g			

MethylHydrosiloxane homopolymers are used as water-proofing agents, reducing agents and as components in some foamed silicone systems.

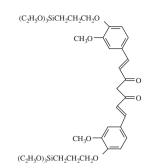
polyMethylHydrosiloxanes, Trimethylsiloxy terminated

Tg: -119° V.T.C: 0.50

CAS: [63148-57-2] TSCA

		Molecular	Mole %	Equivalent	Specific	Refractive		
Code	Viscosity	Weight	(MeHSiO)	Weight	Gravity	Index	Price/100g	Price/3 kg
HMS-991	15-25	1400-1800	100	67	0.98	1.395		
HMS-992	25-35	1800-2100	100	65	0.99	1.396		
HMS-993	35-45	2100-2400	100	64	0.99	1.396		

### **UV Active and Fluorescent Silanes**



 $NH(CH_2)_3Si(OC_2H_5)_3$ 

name

SIB1824.8 BIS(4-TRIETHOXYSILYLPROPYL-3-METHOXY- 777.07 PHENYL)-1,6-HEPTANE-3,5-DIONE tech-90

 $C_{39}H_{60}O_{12}Si_2$ 

UV: 220, 232(max), 354(broad) metal chelating chromophore

HMIS: 2-1-1-X

MW bp/mm (mp)

500mg

 $n_n^{20}$ 10<sup>-3</sup> M in THF

SID4352.0

3-(2,4-DINITROPHENYLAMINO)PROPYL-387.46 (27-30°)mp 1.5665 TRIETHOXYSILANE, 95% N-/3-(TRIETHOXYSILYL)PROPYL]-2,4-DINITROPHENYLAMINE C<sub>15</sub>H<sub>25</sub>N<sub>3</sub>O<sub>7</sub>Si viscous liquid or solid flashpoint: >110°C (230°F)

UV: 222, 258, 350(max), 410

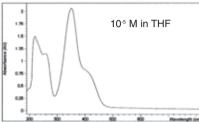
forms  $\chi^2$  non-linear optical sol-gel materials by corona poling<sup>1,2</sup>.

1. E. Toussaere et al, Non-Linear Optics, 2, 37, 1992

2. B. Lebeau et al, J. Mater. Chem., 4, 1855, 1994

[71783-41-0] HMIS: 2-1-0-X

100a



 $CH_3$ (C<sub>2</sub>H<sub>5</sub>O)<sub>2</sub>SiCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>O SIH6198.0

2-HYDROXY-4-(3-METHYLDIETHOXYSILYL-

PROPOXY) DIPHENYLKETONE. 95%

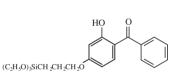
viscosity, 25°: 100-125 cSt.

418.56

 $C_{21}H_{28}O_5Si$ monomer for UV opaque fluids HMIS: 2-1-1-X

25g

1.54525



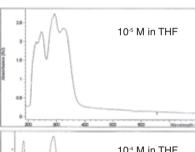
SIH6200.0 2-HYDROXY-4-(3-TRIETHOXYSILYLPROPOXY)-

viscosity, 25°: 125-150 cSt. DIPHENYLKETONE, 95% UV: 230, 248, 296(max), 336  $C_{22}H_{30}O_6Si$ density: 1.12 strong UV blocking agent for optically clear coatings, abosrbs from 210-420nm UV blocking agent<sup>1</sup>.

B. Anthony, US Pat. 4,495,360, 1985

[79876-59-8] TSCA HMIS: 2-1-1-X

25g 100a



(CH<sub>3</sub>CH<sub>2</sub>O)<sub>3</sub>SiCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>NHCO

SIM6502.0

0-4-METHYLCOUMARINYL-N-[3-(TRIETHOXY-SILYL)PROPYL]CARBAMATE

C20H29NO7Si

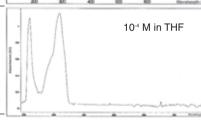
immobilizeable fluorescent compound1. 1. B. Arkles, US Pat. 4,918,200, 1990

[129119-78-4] HMIS: 2-2-1-X

soluble: THF

10g

(88-90°)mp UV: 223, 281, 319.5(max)



(C<sub>2</sub>H<sub>5</sub>O)<sub>3</sub>SiCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>O

SIT8186.2

7-TRIETHOXYSILYLPROPOXY-5-HYDROXY-

FLAVONE

 $C_{24}H_{30}O_7Si$ 

HMIS: 2-1-1-X

458.58

423.54

UV: 350nm (max)

1.0g 5.0g

(C<sub>2</sub>H<sub>5</sub>O)<sub>3</sub>SiCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>HNSO<sub>2</sub>



CH2CH2CH2Si(OCH2CH3)3

SIT8187.0

N-(TRIETHOXYSILYLPROPYL)DANSYLAMIDE 454.66 115-9°/0.1 1.5421

5-DIMETHYLAMINO-N-(3-TRIETHOXYSILYLPROPYL)-

NAPTHALENE-1-SULFONAMIDE viscous liquid - soluble in toluene THF C21H34N2O5SSi density: 1.12 UV: 222(max), 256, 354

fluorescent- employed as a tracer in UV cure composites

fluorescence probe for crosslinking in silicones<sup>1</sup> 1. P. Leezenberg et al, Chem. Mat., 7, 1784, 1995

[70880-05-6] TSCA HMIS: 2-1-1-X 1.0g 0.5q



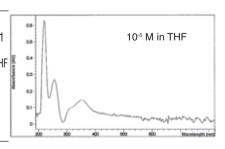
2-(2-TRIETHOXYSILYLPROPOXY-5-METHYL-429.59

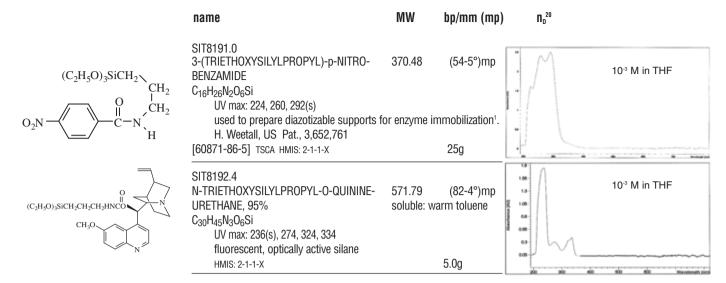
PHENYL)BENZOTRIAZOLE

UV: 300, 330(max) C<sub>22</sub>H<sub>31</sub>N<sub>3</sub>O<sub>4</sub>Si

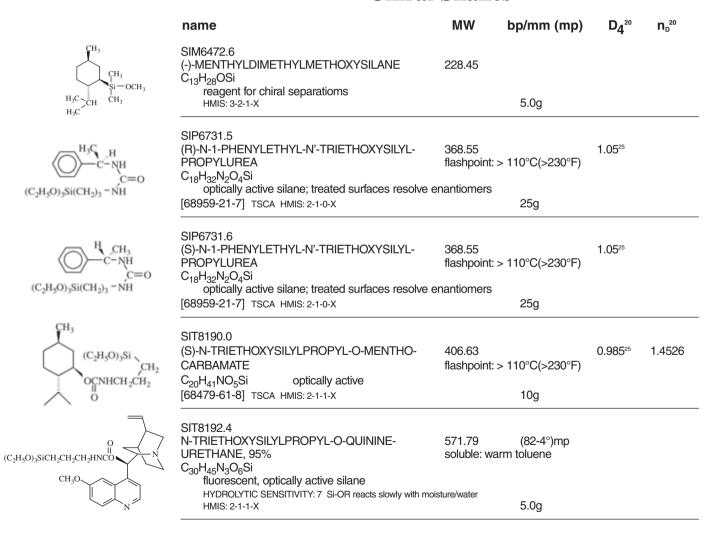
UV blocking agent/stabilizer

HMIS: 2-1-1-X 10g





## **Chiral Silanes**



**Surface Modification with Silanes:** What's not covered in "Hydrophobicity, Hydrophilicity and Silane Surface Modification"?

Silanes which are expected to form covalent bonds after deposition onto surfaces are discussed in the Gelest brochure entitled "Silane Coupling Agents: Connecting Across Boundaries" Aminosilanes which are important in some hydrophilic surface treatments are covered in detail.

#### **Further Reading**

#### Silane Coupling Agents - General References and Proceedings

- 1. B. Arkles, Tailoring Surfaces with Silanes, CHEMTECH, 7, 766-778, 1977.
- 2. E. Plueddemann, "Silane Coupling Agents," Plenum, 2nd edition, 1990.
- 3. K. Mittal, "Silanes and Other Coupling Agents," VSP, 1992.
- 4. D. Leyden and W. Collins, "Silylated Surfaces," Gordon & Breach, 1980.
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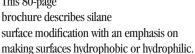
picture courtesy of D. Teff.

## **Additional Product Information on Silanes & Silicones**

### For Material Science:

Hydrophobicity, Hydrophilicity and Silane Surface Modification

Organosilanes are used extensively for modification of surface properties. This 80-page



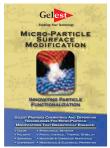


Silane Coupling
Agents
Silane coupling
agents enhance
adhesion, increase
mechanical properties of composites,
improve dispersion
of pigments and
fillers and immobilize catalysts and

biomaterials. This 48 page brochure describes chem-istry, techniques, applications and physical properties of silane coupling agents.

#### Micro-Particle Surface Modification

The surface properties of micro-particles can be altered to match the requirements of various applications. Surface treatment services provided on a custom basis at Gelest are described. This brochure reviews



deposition technologies and silane chemistries provided by Gelest that allow end-users to modify their micro-particles to achieve optimum surface properties for composite, separation, dispersion and other applications.

#### Silicone Fluids-Stable, Inert Media

Design and Engineering properties for conventional silicone fluids as well as thermal, fluorosilicone, hydrophilic and low tempera-



ture grades are presented in a 24 page selection guide. The brochure provides data on thermal, rheological, electrical, mechanical and optical properties for silicones. Silicone fluids are available in viscosities ranging from 0.65 to 2,500,000 cSt.

#### Reactive Silicones -Forging New Polymer Links The 48 page brochure

chure describes reactive silicones that can be formulated into coatings, mem-

branes, cured

rubbers and adhesives for mechanical, optical, electronic and ceramic applica-tions. Information on reactions and cures

of silicones as well as physical properties shortens product development time for chemists and engineers.

#### Silicon Compounds: Silanes and Silicones

Detailed chemical properties and reference articles for over 1600 compounds. The 590 page catalog of silane and sili-



cone chemistry includes scholarly reviews as well as detailed information on various applications.

## For Synthesis:

#### Silicon-Based Blocking Agents

These silicon reagents are used for functional group protection, synthesis and derivatization. The 28 page



brochure presents detailed application information on silylation reagents for pharmaceutical synthesis and analysis. Detailed descriptions are presented on selectivity for reactions, resistance to chemical transformations and selective deblocking conditions. Over 300 references are provided.

#### Silicon-Based Reducing Agents These silicon-based

con-based reagents are employed in the reduction of various organic and inorganic systems. The 24 page brochure



presents information complete with literature references for a variety of reductions using organosilanes.

#### Silicon-Based Cross-Coupling Reagents

A variety of organosilanes have been shown to enter into cross-coupling protocols. This 36 page brochure with 105 refer-



ences reviews selected approaches and some of the key aspects of the organosilane approach to cross-coupling chemistry. An emphasis is placed on the more practical reactions.

